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(54) Title: SELF ALIGNED CONTACTS FOR MONOLITHICALLY ISLED BACK CONTACT BACK JUNCTION SOLAR CELLS

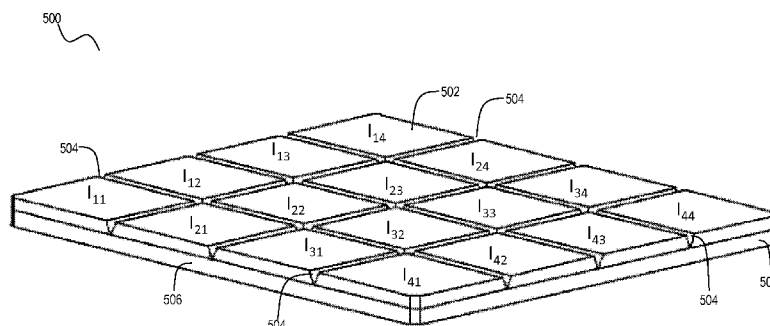


Fig. 30

(57) Abstract: According to one aspect of the disclosed subject matter, a method for forming self aligned contacts for monolithically isled back contact back junction solar cells is provided.



SELF ALIGNED CONTACTS FOR MONOLITHICALLY ISLED BACK CONTACT BACK JUNCTION SOLAR CELLS

CROSS-REFERENCE TO RELATED APPLICATIONS

[001] This application claims the benefit of U.S. provisional patent applications 61/920,271 filed Dec. 23, 2013 and 61/954,116 filed Feb. 26, 2014, all of which are hereby incorporated by reference in their entirety. This application is a continuation-in-part of U.S. utility patent application 14/493,341 filed Sept. 22, 2014 which claims the benefit of U.S. provisional patent application 61/880,777 filed Sept. 20, 2013, all of which are hereby incorporated by reference in their entirety. U.S. utility patent application 14/493,341 is also a continuation-in-part of U.S. utility patent application 14/179,526 filed Feb. 12, 2014 which claims the benefit of U.S. provisional patent applications 61/763,580 filed February 12, 2013 and 61/859,602 filed on July 29, 2013, all of which are hereby incorporated by reference in their entirety. U.S. utility patent application 14/179,526 is also a continuation-in-part of U.S. utility patent application 14/072,759 filed Nov. 5, 2013 which claims the benefit of U.S. provisional patent application 61/722,620 filed on November 5, 2012, which are hereby incorporated by reference in their entirety.

FIELD OF THE INVENTION

[002] The present disclosure relates in general to the fields of solar photovoltaic (PV) cells and modules, and more particularly to monolithically isled or tiled photovoltaic (PV) solar cells and associated modules providing numerous benefits.

BACKGROUND

[003] Crystalline silicon photovoltaic (PV) modules, as of 2012, account for approximately at least 85% of the overall global PV annual demand market and cumulative globally installed PV capacity. The manufacturing process for crystalline silicon PV is based on the use of crystalline silicon solar cells, starting with mono-crystalline or multi-crystalline silicon wafers made of czochralski (CZ) silicon ingots or cast silicon bricks. Non-crystalline-silicon-based thin film PV modules (for example

CdTe, CIGS, organic, and amorphous silicon PV modules) may offer the potential for low cost manufacturing process but typically provide much lower conversion efficiencies (in the range of up to about 14% in STC module efficiency) for commercial thin-film PV modules as compared to the mainstream crystalline silicon PV modules (which may provide module efficiencies in the range of approximately 14% up to about 20%, and mostly in the range of about 14% to 17%), and an unproven long-term track record of field reliability as compared to well-established crystalline silicon solar PV modules. The leading-edge crystalline silicon PV modules offer superior overall energy conversion performance, long-term field reliability, non-toxicity, and life cycle sustainability compared to various other PV technologies. Moreover, recent progress and advancements have driven the overall manufacturing cost of crystalline silicon PV modules to below \$0.80/Wp. Disruptive monocrystalline silicon technologies — such as high-efficiency thin monocrystalline silicon solar cells fabricated using reusable crystalline silicon templates, thin (e.g., crystalline silicon absorber thickness from approximately 10 μm up to about 100 μm , and typically ≤ 70 μm) epitaxial silicon, thin silicon support using backplane attachment / lamination, and porous silicon lift-off technology — offer the promise of high-efficiency (solar cell and/or module efficiencies of at least 20% under Standard Test Conditions or STC) and PV module manufacturing cost at well below \$0.50/Wp at mass manufacturing scale.

[004] Current crystalline silicon (or other semiconductor absorber material) solar cell structures and processing methods often suffer from several disadvantages relating to cell bow and cell cracking / breakage during and/or after cell processing as well as during the operation of crystalline silicon PV modules installed in the field. Solar cell processing often induces significant stresses (e.g., thermal and/or mechanical stresses) on a semiconductor substrate which may lead to thermally-induced warpage and crack generation and propagation (by thermal cycling or mechanical stresses). Bowed or non-planar solar cell substrates pose significant challenges and possible manufacturing yield degradation during solar cell processing (such as during processing of crystalline silicon solar cells), and may present requirements for clamping down the solar cell substrate and/or the substrate edges onto a supporting substrate carrier to flatten the cell substrate during manufacturing process. Flattening solutions may complicate the solar cell

manufacturing process, resulting in increased manufacturing cost and/or some manufacturing throughput and yield compromises. Bowed or non-planar solar cell substrates may further result in cell microcracks and/or breakage problems during module lamination and also subsequently during the PV module operation in the field (resulting in PV module power degradation or loss). These problems may be further aggravated in larger area solar cells, such as the commonly used 156 mm x 156 mm format (square or pseudo square) solar cells.

[005] Further, conventional solar cells, particularly those based on an interdigitated back-contact or IBC design, often require relatively thick metallization patterns — due to the relatively high cell electrical current — which may add complexity to cell processing, increase material costs, and add significant physical stresses to the cell semiconductor material. Thermal and mechanical stresses induced by relatively thick (e.g., in the thickness range of 10's of microns for IBC cell metallization) metallization patterns on the solar cell frontside and/or backside, coupled with the coefficient of thermal expansion or CTE mismatch between conductive metals (e.g., plated copper used for IBC solar cells or screen-printed aluminum-containing and/or silver-containing metallization pastes used for conventional front-contact solar cells) and semiconductor materials (e.g., thin crystalline silicon absorber layer) may substantially increase the risk of producing microcracks, cell breakage, and cell bowing during cell processing (i.e., during and after cell metallization) and module processing (during and after cell-to-cell interconnections and module lamination assembly) as well as during field operation of the installed PV modules (i.e. due to weather conditions, temperature changes, wind-induced and/or snow-load-induced and/or installation-related module bending stresses).

[006] Additionally, crystalline silicon modules often utilize relatively expensive external bypass diodes, which must be capable of handling relatively high forward-biased electrical currents in the range of approximately several amperes up to about 10 amperes and relatively high reverse bias voltages in the range of approximately 10 volts to 20 volts, in order to eliminate hot-spot effects caused by the partial or full shading of solar cells and to prevent the resulting potential solar cell and module reliability failures. Such shade-induced hot-spot phenomena, which are caused by reverse biasing of the shaded cell or cells in a PV module, may permanently damage the affected PV cells as well as

the PV module encapsulation material and cell-to-cell interconnections, and even cause fire hazards, if the sunlight arriving at the surface of the PV cells in a PV module is partially blocked or not sufficiently uniform within the PV module — for instance, due to full or even partial shading of one or a plurality of solar cells. Bypass diodes are often placed on sub-strings of the PV module — typically one external bypass diode per sub-string of 20 solar cells in a standard 60-cell crystalline silicon solar module with three 20-cell sub-strings or one external bypass diode per sub-string of 24 solar cells in a 72-cell crystalline silicon solar module with three 24-cell sub-strings, while many other module formats and configurations with different numbers of embedded solar cells are possible for modules with any number of cells. This connection configuration with external bypass diodes across the series-connected cell strings prevents the reverse bias hot spots due to any shaded cells and enables the PV modules to operate with a relatively high degree of reliability throughout their lifetime under various real life shading or partial shading and soiling conditions. In the absence of solar cell shading or soiling, each cell in the string essentially acts as an electrical current source with relatively matched electrical current values with the other cells in the series-connected string of cells, with the external bypass diode in the sub-string being reversed biased with the total voltage of the sub-string in the module (for example, 20 cells in a series-connected string create approximately about 10V to 12V reverse bias across the bypass diode in a crystalline silicon PV system). With shading of a cell in a string, the shaded cell is reverse biased, turning on the bypass diode for the sub-string containing the shaded cell, thereby allowing the current from the good/non-shaded solar cells in the non-shaded sub-strings to flow in the external bypass circuit. While the external bypass diodes (typically three external bypass diodes included in the standard mainstream 60-cell crystalline silicon PV module junction box) protect the PV module and cells in case of shading of the cells, they can also actually result in significant loss of power harvesting and energy yield for the installed PV systems.

[007] Currently, a majority of silicon solar cells are made using p-type (e.g., boron doped) crystalline silicon wafers (both multi-crystalline and mono-crystalline). Such cells are fragile and may break easily (and thus often must be packaged in rigid, framed, glass-covered modules), suffer from efficiency limits (typical p-type cell efficiency is

limited to about 20%), efficiency degradations (such as Light-Induced Degradation or LID) due to iron boron (Fe-B) and boron-oxygen (B-O) pairings. Much work is being invested into developing foundation technology and transitioning to n-type (e.g., phosphorus doped) starting wafers which do not suffer from the same degradations and enable higher efficiency cells as compared to p-type starting wafers.

[008] Further, the majority of solar modules installed or being produced utilize multi-crystalline or mono-crystalline silicon solar cells which are front contact cells (with frontside or sunnyside fingers and busbars). Such front contact cells may suffer from optical shading losses cause by front side metallization, including metallization fingers and busbars. Back contact architectures circumvent this problem.

[009] The highest efficiency back contact cells employ interdigitated back-contact (IBC), back-junction architectures which enable close proximity between the harvested carriers in the emitter and the terminals and also allow for lightly doped front surfaces which provide good blue response of the cells. Moreover, n-type wafers used for back-contact/back-junction (IBC) solar cells typically provide much higher minority carrier lifetimes compared to p-type wafers, resulting in additional higher cell efficiency upsides.

[010] For best efficiency performance, back contact back junction IBC solar cells typically require very high minority carrier lifetime wafers – thus higher-lifetime n-type wafers are more suitable than p-type wafers for IBC cells. This may be to a large extent owed to the fact that the mean path that the generated minority carriers (for instance, holes in the case of n-type wafers and n-type IBC cell base) travel to be collected at the emitter junction located at the rear side of the cell is relatively large due to the distance to the rear collecting junction terminal from the cell frontside which is governed by the thickness of the wafer or semiconductor absorber layer.

[011] While a certain thickness of the wafer (or semiconductor absorber) is beneficial for effectively harvesting a large fraction of infrared photons (such as those with energies closer to the bandgap energy of crystalline silicon), there is a diminishing return for value-add light absorption with larger absorber thickness, and both bulk recombination losses and the increased travel distance for the generated minority carriers (which are prone to recombination losses) lead to a deterioration of the overall cell efficiency performance as cell absorber thicknesses increase more than a certain optimum range, for

example in the range of approximately 20 and 90 μm for mono-crystalline silicon, depending on the starting wafer quality (minority carrier lifetime or diffusion length). Correspondingly, from a cell efficiency performance point of view, crystalline silicon absorber thicknesses between approximately 20 and 90 μm may be optimal – the actual optimal thickness value depending on the absorber material quality as measured by minority carrier lifetime or diffusion length, and may be somewhat smaller than 20 μm or larger than 90 μm . The practical limitation to producing high-efficiency crystalline silicon cells using very thin wafers (e.g., ≤ 120 μm thickness for 156 mm x 156 mm wafers) is the mechanical yield of such wafers throughout the cell manufacturing process (as well as subsequent module lamination process). The mechanical yield may be decreased due to breakage of such thin wafers during cell fabrication processes and handling, such as screen printing and wet processes, as well as due to breakage from excessive film stress or excessive bow, especially as back contact cells typically require very thick high-conductivity (e.g., plated copper) backside metallization (often many tens of microns thick plated copper to carry the relatively large cell currents, at low voltage, across inter-digitated back-contact, IBC, fingers).

[012] The need for such thick metallization often requires the use of plating, such as electroplating, of Cu or stacks of Ni, Cu and Sn of the metal structures. Introducing electroplating, including copper electroplating, into production has been a substantial technological challenge for solar companies, none the least because of the inherent risk of intrinsic metal contamination of the silicon absorber layer with the metal from the plating solution or during further processing or aging. Moreover, copper plating for IBC cells may require multiple process steps (for example: formation of PVD seed layer, screen printed resist pattern, copper-nickel-tin electroplating, strip resist pattern, wet etch exposed seed) and has significant consumable costs as well as additional fab facilities CAPEX/OPEX costs to support the back-end plating line. The IBC cell requirement for relatively thick plated copper metallization also presents significant risks in terms of stresses introduced by the thick copper due to the thermal (CTE) mismatch between the relatively thick (e.g., 30 to 80 μm thick) plated copper layer and silicon.

[013] These constraints as well as others have kept manufacturing costs for desirable back contact IBC cell architectures relatively high and limited mass adoption.

BRIEF SUMMARY OF THE INVENTION

[014] Therefore, a need has arisen for high efficiency solar cell fabrication methods and designs. In accordance with the disclosed subject matter, methods and structures for monolithically isled solar cells and modules are provided. These innovations substantially reduce or eliminate disadvantages and problems associated with previously developed solar cells.

[015] According to one aspect of the disclosed subject matter, a monolithically isled solar cell is provided. The solar cell comprises a semiconductor layer having a light receiving frontside and a backside opposite the frontside and attached to an electrically insulating backplane. A trench isolation pattern partitions the semiconductor layer into electrically isolated isles on the electrically insulating backplane. A first metal layer having base and emitter electrodes self aligned to base and emitter regions is positioned on the semiconductor layer backside. A patterned second metal layer providing cell interconnection and connected to the first metal layer by via plugs is positioned on the backplane.

[016] These and other advantages of the disclosed subject matter, as well as additional novel features, will be apparent from the description provided herein. The intent of this summary is not to be a comprehensive description of the subject matter, but rather to provide a short overview of some of the subject matter's functionality. Other systems, methods, features and advantages here provided will become apparent to one with skill in the art upon examination of the following **FIGURES** and detailed description. It is intended that all such additional systems, methods, features and advantages included within this description be within the scope of the claims.

BRIEF DESCRIPTION OF THE DRAWINGS

[017] The features, natures, and advantages of the disclosed subject matter may become more apparent from the detailed description set forth below when taken in conjunction with the drawings in which like reference numerals indicate like features and wherein:

[018] **Fig. 1** is a top view diagram of a square-shaped single isle master cell;

[019] **Fig. 2** is a top view diagram of a square-shaped 4x4 isled square master cell (or isled cell “icell”);

[020] **Figs. 3A** and **3B** are cross-sectional diagrams showing a backplane-attached solar cell after solar cell processing steps including isolation trench formation;

[021] **Fig. 4** is a representative process flow for the fabrication of backplane-attached solar cells using epitaxial silicon lift-off processing;

[022] **Figs. 5A** through **5C** are manufacturing process flows for the formation of back-contact back-junction solar cells. **Fig. 5A** shows a process flow based on epitaxial silicon and porous silicon lift-off processing, **Fig. 5B** shows a process flow based on starting crystalline silicon wafers, and **Fig. 5C** shows a process flow based on epitaxial silicon and lift-off processing;

[023] **Figs. 5D** and **5E** are cross-sectional diagrams showing a backplane-attached solar cell;

[024] **Figs. 6A** and **6B** are top view diagrams of a square-shaped 3x3 and 5x5 isled square icell, respectively;

[025] **Figs. 7A** and **7B** are top view diagrams of embodiments a triangular-shaped 8 isled square icell;

[026] **Figs. 7C**, **7D**, and **7E** are top view diagrams of embodiments a triangular-shaped 16, 36, and 32 isled square icell, respectively;

[027] **Fig. 8** is a schematic diagram showing an equivalent circuit model of a typical solar cell with edge effects;

[028] **Fig. 9A** is a backside view diagram showing a busbarless first metallization layer pattern (M1) formed on a square-shaped 4x4 isled icell and **Fig. 9B** is an expanded view of a portion of **Fig. 9A**;

[029] **Figs. 10A and 10B** are backside view diagrams showing a busbarless first metallization layer pattern (M1) formed on a square-shaped 3x3 and 5x5 isled icell, respectively;

[030] **Fig. 11A** is a backside view diagram showing a busbarless first metallization layer pattern (M1) formed on a triangular-shaped 36 isled icell and **Fig. 11B** is an expanded view of a portion of **Fig. 11A**;

[031] **Fig. 12A** is a backside view diagram showing a second metallization layer pattern (M2) formed on a square-shaped 5x5 isled icell and **Fig. 12B** is an expanded view of a portion of **Fig. 12A**;

[032] **Fig. 13** is a backside view diagram showing a second metallization layer pattern (M2) unit cell having interdigitated tapered base and emitter fingers;

[033] **Fig. 14A** is a backside view diagram showing a second metallization layer pattern (M2) formed on a square-shaped 4x4 isled icell and **Fig. 14B** is an expanded view of a portion of **Fig. 14A**;

[034] **Figs. 15A and 15B** are backside view diagrams showing a second metallization layer pattern (M2) formed on a square-shaped 3x3 and 5x5 isled icell, respectively;

[035] **Fig. 16A** is a top view diagram of an isled master cell (icell), each isle having a monolithically-integrated bypass switch (MIBS);

[036] **Figs. 16B and 16C** are cross-sectional diagrams detailing MIBS rim or full-periphery diode solar cell embodiments of the back-contact/back-junction solar cell for one isle (or unit cell such as I_{11} in **Fig. 16A**);

[037] **Fig. 17** is a schematic diagram showing an all-series electrically connected icell;

[038] **Figs. 18A and 18B** are schematic diagrams showing an icell having an all-series electrically connected and hybrid parallel-series electrically connected 4x4 array of isles (the design of **Fig. 18B** referred to as 2x8HPS design);

[039] **Fig. 18C** is a schematic diagram showing an icell having a hybrid parallel-series electrically connected 8x8 array of isles (referred to as 8x8HPS design);

[040] **Figs. 19A, 19B, and 19C** show position of a shade management switch on the icells of **Figs. 18A, 18B, and 18C**, respectively;

[041] **Fig. 20** is a top view diagram of a pseudo-square shaped master cell substrate;

- [042] **Fig. 21** is a schematic diagram showing a pseudo square-shaped icell having a hybrid parallel-series electrical connection;
- [043] **Fig. 22** is a schematic diagram showing a pseudo square-shaped icell having an all-series electrical connection;
- [044] **Figs. 23A** and **23B** are schematic diagrams showing a master cell overview and the relative position of emitter and base busbars depending on the number of isles and M2 interconnection design;
- [045] **Figs. 24** through **27** are schematic diagrams depicting 60-cell module connection designs;
- [046] **Figs. 28A** and **28B** are schematic diagrams showing module connections for 600 VDC PV systems using 60-cell PV modules comprising all-series icells as compared to hybrid parallel-series icells;
- [047] **Figs. 29A** and **29B** are schematic diagrams showing module connections for 1000 VDC PV systems using 60-cell PV modules comprising all-series icells as compared to hybrid parallel-series icells;
- [048] **Fig. 30** is a diagram of monolithically isled solar cell having a 4 x 4 array of sub-cells;
- [049] **Fig. 31** is a graph of cell thickness vs open circuit voltage;
- [050] **Fig. 32** is a graph of minority carrier lifetime vs silicon thickness;
- [051] **Fig. 33** is a process flow diagram illustrating high-level solar cell building blocks;
- [052] **Figs. 34A** through **34D** are process flow embodiments for the manufacture of interdigitated back contact solar cells with no FSF or BSF;
- [053] **Figs. 35A** through **35D** are process flow embodiments for the manufacture of interdigitated back contact solar cells with a buried BSF;
- [054] **Figs. 36A** through **36D** are process flow embodiments for the manufacture of interdigitated back contact solar cells with a buried BSF;
- [055] **Fig. 37A** illustrates cross-sectional diagrams showing a process comprising a wafer thinning step prior to wafer segmentation;
- [056] **Fig. 37B** illustrates cross-sectional diagrams showing a process comprising partial wafer segmentation prior to wafer thinning and following wafer thinning and texturing;

- [057] **Figs. 38A** through **38D** are process flow embodiments for the manufacture of interdigitated back contact solar cells with laser-doped FSF;
- [058] **Figs. 39A** through **39D** are process flow embodiments for the manufacture of interdigitated back contact solar cells with pulsed laser FSF;
- [059] **Figs. 40A** through **40D** are process flow embodiments for the manufacture of interdigitated back contact solar cells with ion implantation FSF;
- [060] **Figs. 41A** through **41D** are process flow embodiments for the manufacture of interdigitated back contact solar cells with gas immersion FSF;
- [061] **Fig. 42** is a process flow embodiment for the manufacture of interdigitated back contact solar cells with pulsed ns laser scribing of isolation trenches using PV-Al/NiV;
- [062] **Fig. 43** is a process flow embodiment for the manufacture of interdigitated back contact solar cells using pulsed ns laser scribing of isolation trenches on pre-etch thick silicon;
- [063] **Fig. 44A** is a cross-sectional diagram showing direct oxide ablation of a BSG (or PSG) layer on a silicon layer;
- [064] **Fig. 44B** is a cross-sectional diagram showing ablation of a hardmask layer on a BSG 9or PSG) layer on a silicon layer;
- [065] **Figs. 45** through **49** show several representative process flow embodiments for the fabrication of a backplane-attached back contact solar cell;
- [066] **Figs. 50A** through **53** are solar cell fabrication process flow embodiments for the formation of a back contact back junction solar cell utilizing a triple print dopant paste process for field emitter, base, and emitter formation;
- [067] **Figs. 54A** through **56B** are solar cell fabrication process flow embodiments for the formation of a back contact back junction solar cell utilizing a double print dopant paste process for base and emitter formation;
- [068] **Figs. 57A** through **59** are solar cell fabrication process flow embodiments for the formation of a back contact back junction solar cell utilizing a cascade process (deposition followed by patterning) forming field emitter, emitter, and base regions;
- [069] **Figs. 60** and **61** are solar cell fabrication process flow embodiments for the formation of a back contact back junction solar cell utilizing a single cascade process and tunnel contacts;

[070] **Fig. 62** is a solar cell fabrication process flow embodiment for the formation of a back contact back junction solar cell utilizing a single cascade process and tunnel contacts starting with an epitaxial thin film silicon substrate formation; and

[071] **Figs. 63A through 63D** are cross-sectional diagrams of solar cells with a self aligned contact structure;

[072] **Figs. 64A through 64E** are cross-sectional diagrams of solar cells at various steps during the fabrication of a abutted junction interdigitated back contact solar cell having self aligned contacts;

[073] **Figs. 65A through 65G** are cross-sectional diagrams of solar cells at various steps during the fabrication of a non abutted junction interdigitated back contact solar cell having self aligned contacts; and

[074] **Figs. 66A through 66E** are cross-sectional diagrams of solar cells at various steps during the fabrication of a non abutted junction interdigitated back contact solar cell having self aligned contacts.

DETAILED DESCRIPTION

[075] The following description is not to be taken in a limiting sense, but is made for the purpose of describing the general principles of the present disclosure. The scope of the present disclosure should be determined with reference to the claims. Exemplary embodiments of the present disclosure are illustrated in the drawings, like numbers being used to refer to like and corresponding parts of the various drawings.

[076] Importantly, the exemplary dimensions and calculations disclosed for embodiments are provided both as detailed descriptions for specific embodiments and to be used as general guidelines when forming and designing solar cells in accordance with the disclosed subject matter.

[077] And although the present disclosure is described with reference to specific embodiments, such as backplane-attached / back-contact solar cells such as interdigitated back-contact (IBC) solar cells using monocrystalline silicon substrates and other described fabrication materials, one skilled in the art could apply the principles discussed herein to other solar cells including but not limited to non-IBC back-contact solar cells (such as Metallization Wrap-Through or MWT back-contact solar cells, traditional front contact cells, other fabrication materials including alternative semiconductor materials (such as materials comprising one or a combination of silicon, gallium arsenide, germanium, gallium nitride, other binary and ternary semiconductors, etc.), technical areas, and/or embodiments without undue experimentation.

[078] Further, while the isled (also called tiled) master cell architectures (also referred to herein as icell, an acronym for Isled Cell) and representative manufacturing process flow descriptions are described with reference to thin epitaxial silicon back-contact/back-junction IBC solar cells formed using porous silicon lift-off processing on reusable monocrystalline templates and flexible backplanes, the novel concepts and embodiments disclosed herein can also be applied and effectively utilized in numerous other types of solar cells (and resulting solar PV modules) including, but not limited to:

- Thin epitaxial silicon back-contact/back-junction IBC solar cells formed using porous silicon lift-off processing on reusable multi-crystalline templates, and either flexible or rigid backplanes;

- Thin epitaxial silicon back-contact/back-junction IBC solar cells formed using porous silicon lift-off processing on reusable monocrystalline templates and relatively rigid backplanes;
- Thin epitaxial Silicon Heterojunction (SHJ) solar cells formed using porous silicon lift-off processing on reusable multi-crystalline templates, and either flexible or rigid backplanes;
- Back-junction/back-contact IBC solar cells formed using wire-sawn Czochralski (CZ) or Float-Zone (FZ) monocrystalline wafers and flexible backplanes;
- Back-junction/back-contact IBC solar cells formed using wire-sawn Czochralski (CZ) or Float-Zone (FZ) monocrystalline wafers and rigid backplanes;
- Back-junction/back-contact IBC solar cells formed using wire-sawn cast or ribbon multi-crystalline wafers, and flexible backplanes;
- Back-junction/back-contact IBC solar cells formed using wire-sawn cast or ribbon multi-crystalline wafers, and rigid backplanes;
- Back-contact non-IBC (e.g., Metallization Wrap-Through or MWT) solar cells formed using wire-sawn cast multi-crystalline wafers and flexible backplanes;
- Back-contact non-IBC (e.g., Metallization Wrap-Through or MWT) solar cells formed using wire-sawn cast multi-crystalline wafers and rigid backplanes;
- Back-contact non-IBC (e.g., Metallization Wrap-Through or MWT) solar cells formed using wire-sawn Czochralski (CZ) or Float-Zone (FZ) monocrystalline wafers and flexible backplanes;
- Back-contact non-IBC (e.g., Metallization Wrap-Through or MWT) solar cells formed using wire-sawn Czochralski (CZ) or Float-Zone (FZ) monocrystalline wafers and rigid backplanes;
- Semiconductor Heterojunction (SHJ) solar cells formed using wire-sawn Czochralski (CZ) or Float-Zone (FZ) monocrystalline wafers and flexible backplanes;
- Semiconductor Heterojunction (SHJ) solar cells formed using wire-sawn Czochralski (CZ) or Float-Zone (FZ) monocrystalline wafers and rigid backplanes;

- Front-contact solar cells formed using wire-sawn Czochralski (CZ) or Float-Zone (FZ) monocrystalline wafers and flexible backplanes;
- Front-contact solar cells formed using wire-sawn Czochralski (CZ) or Float-Zone (FZ) monocrystalline wafers and rigid backplanes;
- Front-contact solar cells formed using wire-sawn cast monocrystalline wafers and flexible backplanes;
- Front-contact solar cells formed using wire-sawn cast monocrystalline wafers and rigid backplanes; and
- Any of the above-mentioned solar cells using a different semiconductor material other than crystalline silicon.

[079] The terms isle, island, tile, paver, sub-cell, and/or mini-cell are used interchangeably herein to describe the electrically and physically isolated individual semiconductor regions formed monolithically from a master cell substrate (i.e., an initial continuous semiconductor substrate) attached to a common or continuous backplane layer or sheet. The term isled master cell, icell, or modified main cell refers to the plurality of isles or sub-cells formed from the same original semiconductor substrate layer and the subsequent modified isled solar cell. The original semiconductor layer or substrate from which the mini-cells are formed may be referred to as a master cell.

[080] Further, term backplane may be used herein to describe a combination of materials on the cell backside – such as metallization layers and electrically insulating layer attached to the solar cell backside – providing mechanical and structural support to a master cell (and its plurality of isles or mini-cells), and to enable an advanced solar cell interconnection design. Alternatively and in some instances, the term backplane may be used to describe a material layer, such as an electrically insulating flexible prepreg layer, formed and positioned on the backside of the solar cell, hence, enabling a solar cell metallization structure comprising at least two metallization layers on the cell backside. The backplane layer may be made of either a rigid or flexible thin sheet of material (for instance, with backplane sheet thickness in the range of up to about 250 microns). For applications involving back-contact solar cells (including either interdigitated back-contact – IBC or metallization-wrap-through – MWT), the backplane layer may be made

of an electrically insulating material (either a flexible or a rigid material). For applications involving front-contact solar cells, the backplane layer may be either electrically or electrically conducting. In most instances, the term backplane refers to the continuous thin sheet of support material, including but not limited to a thin sheet of prepreg material, which can be either flexible or rigid. The use of flexible backplane sheet in conjunction in accordance with the disclosed subject matter also enables packaging the solar cells in flexible, lightweight PV modules (not requiring much heavier glass cover sheets for frontside or for both frontside and backside).

[081] The present application provides various structures and methods for monolithic isled solar cells and modules. The term monolithic integrated circuit is used to describe a plurality of semiconductor devices and corresponding electrical interconnections that are fabricated onto a slice of semiconductor material layer, also known as the semiconductor substrate. Hence, a monolithic integrated circuit is typically manufactured on a thin continuous slice or layer of a semiconductor material such as crystalline silicon. The monolithic icell structures described herein are monolithic semiconductor integrated circuits as the integrated sub-cells are all formed or manufactured on a slice of semiconductor substrate layer (from either a starting semiconductor wafer or a grown semiconductor layer formed by a vapor-phase or liquid-phase growth method such as epitaxial deposition). Further, the combination of a continuous backplane attached to the semiconductor substrate layer backside enables monolithic integrated icell embodiments in accordance with the disclosed subject matter.

[082] Physically or regionally isolated isles (i.e., the initial semiconductor substrate partitioned into a plurality of substrate isles supported on a shared continuous backplane) are formed from one initially continuous semiconductor layer or substrate – thus the resulting isles (for instance, trench isolated from one another using trench isolation regions or cuts through the semiconductor substrate) are monolithic – attached to and supported by a continuous backplane (for example a flexible backplane such as an electrically insulating prepreg layer). The completed solar cell comprises a plurality of monolithically integrated isles or mini-cells, in some instances attached to a flexible backplane (e.g., one made of a prepreg materials, for example having a relatively good Coefficient of Thermal Expansion or CTE match to that of the semiconductor substrate

material), providing increased solar cell flexibility and pliability while suppressing or even eliminating micro-crack generation and crack propagation or breakage in the semiconductor substrate layer. Further, a flexible monolithically isled (or monolithically integrated group of isles) cell (also called an icell) provides improved cell planarity and relatively small or negligible cell bow throughout solar cell processing steps such as any optional semiconductor layer thinning etch, texture etch, post-texture clean, PECVD passivation and anti-reflection coating (ARC) processes (and in some processing embodiments also allows for sunny-side-up PECVD processing of the substrates due to mitigation or elimination of thermally-induced cell warpage), and final solar cell metallization. While the solar cells disclosed herein may be used to produce rigid glass-covered PV modules, the structures and methods disclosed herein also enable flexible, lightweight PV modules formed from the monolithic isled master cells (i.e., icells) which substantially decrease or eliminate solar cell micro-cracking during module lamination and also during PV module operation in the field. These flexible, lightweight PV modules may be used in a variety of markets and applications including, but not limited to, the residential rooftop (including residential Building-Integrated Photovoltaics or BIPV rooftop shingles / tiles), commercial rooftop, ground mount utility-scale power plants, portable and transportable PV power generation, automotive (such as solar PV sunroof), and other specialty applications.

[083] Aspects of the innovations disclosed herein, either individually or in combination, may provide the following advantages among others:

- An isled solar cell (icell) enables scaling of the solar cell voltage and current, specifically scaling up the solar cell voltage (in other words increasing the master cell output voltage) and scaling down the solar cell current (in other words decreasing the master cell output current) based on the number (e.g., $N \times N$ array) of cell isles/tiles (or sub-cells) which, among numerous other advantages including reduced metallization sheet conductance or thickness requirements (hence, reduced metallization material and process cost), lowers the maximum electrical current rating requirement for associated embedded power electronics components such as the embedded shade management diodes (e.g., lower current rating Schottky or pn junction diodes), or the embedded Maximum-Power-Point

Tracking (MPPT) power optimizers (such as embedded MPPT DC-to-DC micro-converters or MPPT DC-to-AC micro-inverters). This may reduce the sizing (e.g., footprint and/or package thickness) and cost of embedded power electronics components such as the bypass switches (bypass switches with higher current ratings typically have higher costs as compared to bypass switches with lower current ratings), and improve the embedded power electronics device (such as the bypass switch used for distributed shade management, or the MPPT power optimizer used for distributed enhanced power / energy harvest from the PV module) performance due to the reduced electrical current (for instance, flowing through the bypass switch when it is activated and forward-biased to protect a shaded solar cell). A lower-rated current (for example, about 1 to 2 A) Schottky barrier diode typically costs much less, can have a much smaller package, and dissipates much less power than a 10 A to 20 A Schottky barrier diode. The embodiments disclosed herein (for instance, using $N \times N$ isles for the master cell or icell), with icell electrical interconnection configured to provide higher cell voltage (with a scale-up factor of up to $N \times N$) and lower cell current (with a scale-down factor of up to $N \times N$) can reduce the resulting solar cell current while increasing the solar cell voltage for the same solar cell power in order to enable the use of lower cost, smaller, and less power-dissipating bypass diode. For example, consider a crystalline silicon master cell or icell with a maximum-power-point voltage of $V_{mp} \approx 0.60V$ and maximum-power-point current of $I_{mp} \approx 9.3A$ (with the solar cell producing a maximum-power-point power of $P_{mp} \approx 5.6 W$). A master cell or icell with a 5×5 array of mini-cells ($N = 5$), with all the isles or sub-cells connected in electrical series ($S = 25$), for example using a combination of a first level metal (M1) on the backside of the solar cell and a second level metal (M2) on an electrically insulating backplane layer as described further herein, will result in a modified cell with $V_{mp} = 15V$ and $I_{mp} = 0.372A$ – in other words, the master cell or icell voltage is scaled up by a factor of 25 and the master cell or icell current is scaled down by the same factor of 25 (compared to the solar cell of the same master cell size but without the icell structures disclosed herein).

- Higher conversion-efficiency, embedded / distributed lower cost, and smaller footprint Maximum-Power-Point Tracking (MPPT) power optimizer (DC-to-DC or DC-to-AC) chips with superior performance such as dynamic range response may be embedded within the module laminate and/or integrated directly on the backsides of the solar cells (for instance, on the backplanes of the backplane-attached icells disclosed herein) due to the higher voltage and lower current master cell (icell) made of a plurality of isles or mini-cells. In one embodiment, the icell may use an inexpensive single-chip MPPT power optimizer (DC-to-DC micro-converter or DC-to-AC micro-inverter).
- Allows for inexpensive implementation of distributed cell-level integrated shade management an embedded bypass switch connected to each icell, providing higher effective energy yield for the installed PV modules in the field. In one embodiment, this may comprise a monolithically integrated bypass switch (MIBS) formed peripherally around each isle so that during partial shading only the affected/shaded tiles or mini-cells are shunted while the remaining ones produce and deliver electrical power.
- The scaled down electrical current of an isled solar cell (an icell) – for instance, decreased by a factor of $N \times N$ isles – decreases the required patterned metallization sheet conductance and thickness due to the reduced ohmic losses. In other words, the metallization sheet conductance and thickness requirements are relaxed due to substantially reduced ohmic losses. A thinner solar cell metallization structure has a number of benefits relating to solar cell processing and may provide significant manufacturing cost reduction (for instance, much less metallization material required per cell) as well as reducing thermal and mechanical stresses relating to relatively thick (e.g., 10's of microns for interdigitated back-contact or solar cells) metallization structures and the CTE mismatch between conductive metal and semiconductor material. Usually the metallization materials such as copper or aluminum have much higher CTE compared to the semiconductor materials. For instance, linear CTEs of aluminum, copper, and silver (high-conductivity metals) are about 23.1 ppm/°C, 17 ppm/°C, and 18 ppm/°C, respectively. However, the linear CTE of silicon is around 3

ppm/°C. Therefore, there is a relatively large CTE mismatch between these high-conductivity metallization materials and silicon. These relatively large CTE mismatches between the metallization materials and silicon can cause serious cell manufacturing yield and PV module reliability problems, particularly when using relatively thick metallization structures for solar cells (such as thick plated copper used in the IBC solar cells).

- In a multi-layer metallization pattern, such as the dual layer metallization patterns described herein for interdigitated back-contact (IBC) solar cells, the second level metal (M2), for example comprising aluminum or copper, can be made much thinner due to the current and voltage scaling of the icell architecture, and thus deposited without wet plating and using a process which is substantially less mechanically stressful on the cell and chemically intrusive to the cell (for example a dry processing method such as physical-vapor deposition - PVD such as metal evaporation and/or plasma sputtering - or metal paste screen printing or metal ink printing by inkjet printing, etc.).
- In some instances, the cost of material forming the backplane (such as prepreg) is reduced as the icell architecture using a plurality of flexible isles reduces/relaxes the CTE requirements of the prepreg (for instance, by relaxing the relative CTE matching requirement between the backplane layer and semiconductor substrate). Relative CTE matching requirements between the backplane sheet and the semiconductor substrate are reduced as there is less continuous cell area attached to the backplane (because of the trench isolation regions partitioning the semiconductor substrate into a plurality of isles or sub-cells on the continuous backplane sheet) – the continuous mini-cell area attached to the continuous backplane is defined by the isle area or region surrounded by trench isolation.
- Trench separated and electrically partitioned substrate regions for isles provide relative flexibility, further mitigate cell bow, and maintain relative planarity across the master cell (entire icell area) during cell processing (and in some instances also allowing for cell passivation processing such as sunnyside-up cell PECVD deposition) and reduce long term material stresses after cell fabrication,

module lamination, and during the operation of the PV modules in the field under varying weather conditions.

[084] Important applications of the disclosed innovations include but are not limited to: flexible solar cells and flexible, lightweight PV modules for the residential rooftop, Building-Integrated PhotoVoltaics (BIPV) in residential and commercial buildings, commercial rooftop, ground-mount utility-scale power plants, automotive applications, portable electronics, portable and transportable power generation, and other specialty applications. The embodiments disclosed herein include both rigid or flexible solar cells which may be packaged or laminated into rigid glass-covered solar PV modules for a wide range of applications, including the above-mentioned residential rooftop, commercial rooftop, BIPV, ground-mount utility, automotive, portable and transportable power generation, and other specialty applications.

[085] **Fig. 1** is a representative schematic diagram of a square-shaped single isle for cell pattern – prior art standard solar cell geometry without plurality of isles to create an icell. Although shown as a full-square-shaped cell here, the solar cell may be shaped as pseudo square, rectangular, other polygonal shapes, or any other geometrical shape of interest.

Fig. 1 is a schematic diagram showing a top or plan view of a single-isle **I** (or non-isled or non-tiled) standard square-shaped solar cell **10** defined by cell peripheral boundary or edge regions **12** and having a side length **L**. Current or mainstream crystalline silicon solar cells are often rectangular/square shaped (mostly either full square or pseudo square shaped wafers) with cell square area on the order of X by X (with X typically being in the range of about 100 mm up to 210 mm or even larger values), for example, 125 mm x 125 mm or 156 mm x 156 mm or 210 mm x 210 mm solar cells. And although a square shaped solar cell is used as an exemplary master cell (master cell is defined as a single solar cell made from an original continuous semiconductor substrate) shape herein, master cells may come in various shapes (for example pseudo-square) and have various geometrical dimensions.

[086] Cell peripheral boundary or edge region **12** has a total length of $4L$, thus solar cell **10** has a total peripheral dimension of $4L$. Assuming a solar cell semiconductor (e.g., silicon substrate layer) absorber thickness of W (see the cross-sectional diagram of **Fig. 3A**), the cell edge area as a fraction of the cell active area is defined as the ratio R where

$R = (4LW)/(L^2) = 4W/L$. For a thin-silicon solar cell having $L = 156$ mm and $W = 40$ μm (microns) thick silicon substrate (for example an epitaxially grown silicon also known as epi, layer, or alternatively a silicon layer formed from an original wire-sawn CZ or FZ or multi-crystalline silicon wafer): $R = 4 \times 40 \times 10^{-3}/156$, thus $R = 0.0010$ (or 0.10%). And for a more conventional standard solar cell with $W = 200$ μm thick silicon substrate (for example, from a CZ monocrystalline wafer or a cast multicrystalline wafer): $R = 0.0050$ (or 0.50%). Generally, a solar cell structure should have a relatively small edge area as compared to active cell area (also called edge to cell ratio) – for instance, less than about 5%, and in some instances less than about 1% – in order to minimize the edge-related solar cell recombination losses which may result in reduced open-circuit voltage and/or reduced short-circuit current, and hence, reduced solar cell conversion efficiency. The edge-induced losses can be substantially mitigated by proper passivation of the solar cell edge regions and through isolation / separation of the emitter junction region from the edge region (hence, providing allowance for larger edge area fraction without loss of solar cell efficiency).

[087] **Fig. 2** is a representative schematic plan view (frontside or sunnyside view) diagram of an icell pattern (shown for square-shaped isles and square-shaped icell) along with uniform-size (equal-size) square-shaped isles for $N \times N = 4 \times 4 = 16$ isles (or sub-cells, mini-cells, tiles). This schematic diagram shows a plurality of isles (shown as $4 \times 4 = 16$ isles) partitioned by trench isolation regions. **Fig. 2** is a schematic diagram of a top or plan view of a 4×4 uniform isled (tiled) master solar cell or icell **20** defined by cell peripheral boundary or edge region **22**, having a side length **L**, and comprising sixteen (16) uniform square-shaped isles formed from the same original continuous substrate and identified as I_{11} through I_{44} attached to a continuous backplane on the master cell backside (backplane and solar cell backside not shown). Each isle or sub-cell or mini-cell or tile is defined by an internal isle peripheral boundary (for example, an isolation trench cut through the master cell semiconductor substrate thickness and having a trench width substantially smaller than the isle side dimension, with the trench width no more than 100's of microns and in some instances less than or equal to about 100 μm – for instance, in the range of a few up to about 100 μm) shown as trench isolation or isle partitioning borders **24**. Main cell (or icell) peripheral boundary or edge region **22** has a total

peripheral length of $4L$; however, the total icell edge boundary length comprising the peripheral dimensions of all the isles comprises cell peripheral boundary **22** (also referred to as cell outer periphery) and trench isolation borders **24**. Thus, for an icell comprising $N \times N$ isles or mini-cells in a square-shaped isle embodiment, the total icell edge length is $N \times$ cell outer periphery. In the representative example of **Fig. 2** showing an icell with $4 \times 4 = 16$ isles, $N = 4$, so total cell edge length is $4 \times$ cell outer periphery $4L = 16L$ (hence, this icell has a peripheral dimension which is 4 times larger than that of the standard prior art cell shown in **Fig. 1**). For a square-shaped master cell or icell with dimensions $156 \text{ mm} \times 156 \text{ mm}$, square isle side dimensions are approximately $39 \text{ mm} \times 39 \text{ mm}$ and each isle or sub-cell has an area of 15.21 cm^2 per isle.

[088] **Figs. 3A** and **3B** are representative schematic cross-sectional view diagrams of a backplane-attached solar cell during different stages of solar cell processing. **Fig. 3A** shows the simplified cross-sectional view of the backplane-attached solar cell after processing steps and before formation of the partitioning trench regions. **Fig. 3B** shows the simplified cross-sectional view of the backplane-attached solar cell after some processing steps and after formation of the partitioning trench regions to define the trench-partitioned isles. **Fig. 3B** shows the schematic cross-sectional view of the icell of **Fig. 2** along the view axis A of **Fig. 2** for an icell pattern (shown for square-shaped isles and square-shaped icell), indicating the uniform-size (equal-size) square-shaped isles for $N \times N = 4 \times 4 = 16$ isles (or sub-cells, mini-cells, tiles).

[089] **Figs. 3A** and **3B** are schematic cross-sectional diagrams of a monolithic master cell semiconductor substrate on a backplane before formation of trench isolation or partitioning regions, and a monolithic isled or tiled solar cell on a backplane formed from a master cell after formation of trench isolation or partitioning regions, respectively. **Fig. 3A** comprises semiconductor substrate **30** having width (semiconductor layer thickness) **W** and attached to backplane **32** (e.g., an electrically insulating continuous backplane layer, for instance, a thin flexible sheet of prepreg) similar to that shown in **Fig. 1**. **Fig. 3B** is a cross-sectional diagram of an isled solar cell (icell) – shown as a cross-sectional diagram along the A axis of the cell of **Fig. 2**. Shown, **Fig. 3B** comprises isles or mini-cells I_{11} , I_{21} , I_{31} , and I_{41} each having a trench-partitioned semiconductor layer width (thickness) **W** and attached to backplane **32**. The semiconductor substrate regions of the

mini-cells are physically and electrically isolated by an internal peripheral partitioning boundary, trench partitioning borders **24**. The semiconductor regions of isles or mini-cells I_{11} , I_{21} , I_{31} , and I_{41} are monolithically formed from the same continuous semiconductor substrate shown in **Fig. 3A**. The icell of **Fig. 3B** may be formed from the semiconductor / backplane structure of **Fig. 3A** by forming internal peripheral partitioning boundaries in the desired mini-cell shapes (e.g., square shaped mini-cells or isles) by trenching through the semiconductor layer to the attached backplane (with the trench-partitioned isles or mini-cells being supported by the continuous backplane). Trench partitioning of the semiconductor substrate to form the isles does not partition the continuous backplane sheet, hence the resulting isles remain supported by and attached to the continuous backplane layer or sheet. Trench partitioning formation process through the initially continuous semiconductor substrate thickness may be performed by, for example, pulsed laser ablation or dicing, mechanical saw dicing, ultrasonic dicing, plasma dicing, water jet dicing, or another suitable process (dicing, cutting, scribing, and trenching may be used interchangeably to refer to the process of trench isolation process to form the plurality of isles or mini-cells or tiles on the continuous backplane). Again, the backplane structure may comprise a combination of a backplane support sheet in conjunction with a patterned metallization structure, with the backplane support sheet providing mechanical support to the semiconductor layer and structural integrity for the resulting icell (either a flexible solar cell using a flexible backplane sheet or a rigid solar cell using a rigid backplane sheet or a semi-flexible solar cell using a semi-flexible backplane sheet). Again, while we may use the term backplane to the combination of the continuous backplane support sheet and patterned metallization structure, more commonly we use the term backplane to refer to the backplane support sheet (for instance, an electrically insulating thin sheet of prepreg) which is attached to the semiconductor substrate backside and supports both the icell semiconductor substrate regions and the overall patterned solar cell metallization structure.

[090] As previously noted, crystalline (both mono-crystalline and multi-crystalline) silicon photovoltaics (PV) modules currently account for over approximately 85% of the overall global solar PV market, and the starting crystalline silicon wafer cost of these crystalline silicon PV modules currently constitutes about 30% to 50% of the total PV

module manufacturing cost (with the exact ratio depending on the technology type and various economic factors). And while the primary embodiments provided herein are described as back-contact / back-junction (Inter-digitated Back-Contact or IBC) solar cells, the monolithic isled solar cell (or icell) innovations disclosed herein are extendible and applicable to various other solar cell architectures such as Metallization Wrap-Through (MWT) back-contact solar cells, Semiconductor HeteroJunction (SHJ) solar cells, front-contact/back-junction solar cells, front-contact/front-junction solar cells, Passivated Emitter and Rear Contact (PERC) solar cells, as well as other front-contact/front-junction solar cells, with all of the above-mentioned cell designs using crystalline silicon (for instance, either mono-crystalline silicon or multi-crystalline silicon with final cell silicon layer thickness in the range of a few microns up to about 200 microns), or another crystalline (mono-crystalline or multi-crystalline) semiconductor absorber material (including but not limited to germanium, gallium arsenide, gallium nitride, or other semiconductor materials, or a combination thereof). The monolithic isled solar cell (or icell) innovations disclosed herein are extendible and applicable to compound semiconductor multi-junction solar cells.

[091] A key advantage of the disclosed monolithically isled solar cells or icells is that they may be monolithically fabricated during cell processing and easily integrated into existing solar cell fabrication process flows. The isled master cell embodiments disclosed herein may be used in conjunction with numerous backplane-attached solar cell designs, processing methods, and semiconductor substrate materials, including the backplane-attached, back-contact solar cells fabricated using epitaxial silicon lift-off process flow shown in **Fig. 4**. **Fig. 4** shows the schematic diagram of a general back-contact solar cell manufacturing process flow highlighting key processing steps of one such cell fabrication process – a crystalline-silicon solar cell manufacturing process using relatively thin (in the thickness range of a few microns up to about 100 microns) epitaxial silicon lift-off processing which substantially reduces silicon material usage and eliminates several process steps in the traditional crystalline silicon solar cell manufacturing steps to create low-cost, high-efficiency, back-junction/back-contact crystalline silicon solar cells and modules. Specifically, the process flow of **Fig. 4** shows the fabrication of backplane-attached crystalline silicon solar cells having backplanes

attached to the backsides of the solar cells (for instance, prepreg backplane sheets laminated to the backsides of the solar cells) for solar cells and modules with optional allowances for smart cell and smart module design (i.e., allowing for embedded distributed electronics components for enhanced power harvest from the solar cells and modules), formed using a reusable crystalline (either mono-crystalline or multi-crystalline) silicon template and epitaxial silicon deposition on a seed and release layer of porous silicon, which may utilize and integrate the monolithically isled cell (icell) structures and methods disclosed herein.

[092] The solar cell process flow of **Fig. 4** may be used to form monolithic isled solar cells or icells. The process shown in **Fig. 4** starts with a reusable (to be reused at least a few times, in some instances between about 10 up to about 100 times) crystalline silicon template, for example a p-type monocrystalline or multi-crystalline silicon wafer, onto which a thin (a fraction of micron up to several microns) sacrificial layer of porous silicon with controlled porosity is formed (for example by an electrochemical etch process for template surface modification in an HF/IPA or HF/acetic acid wet chemistry in the presence of an electrical current). The porous silicon layer may have at least two layers with a lower porosity surface layer and a higher porosity buried layer. The starting material or reusable crystalline silicon template may be a single crystalline (also known as mono-crystalline) silicon wafer, for example formed using crystal growth methods such as float zone (FZ), czochralski (CZ), magnetic stabilized CZ (MCZ), and may further optionally comprise epitaxial layers grown over such silicon wafers.

Alternatively, the starting material or reusable crystalline silicon template may be a multi-crystalline silicon wafer, for example formed using either casting or ribbon, and may further optionally comprise epitaxial layers grown over such silicon wafers. The template semiconductor doping type may be either p or n (often relatively heavy p-type doping to facilitate porous silicon formation), and the wafer shape, while most commonly square shaped, may be any geometric or non-geometric shape such as quasi-square (pseudo square), hexagonal, round, etc.

[093] Upon formation of the sacrificial porous silicon layer, which serves both as a high-quality epitaxial seed layer as well as a subsequent separation/lift-off layer for the resulting epitaxial silicon layer, a thin layer (for example a layer thickness in the range of

a few microns up to about 100 microns, and in some instances an epitaxial silicon thickness less than approximately 50 microns) of in-situ-doped (for instance, doped with phosphorus to form a n-type epitaxial silicon layer) crystalline (either mono-crystalline or multi-crystalline) silicon is formed on the sacrificial porous silicon layer, also called epitaxial growth. The in-situ-doped crystalline (either mono-crystalline layer on mono-crystalline template or multi-crystalline layer on multi-crystalline template) silicon layer may be formed, for example, by atmospheric-pressure epitaxy using a chemical-vapor deposition or CVD process in ambient comprising a silicon gas such as trichlorosilane or TCS and hydrogen (and the desired dopant gas such as PH_3 for n-type phosphorus doping).

[094] After completion of a portion of solar cell processing steps (including in some instances, backside doped emitter formation, backside passivation, doped base and emitter contact regions for subsequent metallization contacts to the base and emitter regions, and solar cell metallization), a rather inexpensive backplane layer may be attached to the thin epi layer for permanent cell support and reinforcement as well as to support formation of the high-conductivity cell metallization structure of the solar cell (for instance, using a two-layer metallization structure using a patterned first layer of metallization or M1 on the solar cell backside prior to the backplane attachment and a patterned second layer of metallization or M2 on the backside of the backplane-attached solar cell after the backplane attachment and after the lift-off release of the backplane-attached solar cell from the reusable template). The continuous backplane material may be made of a thin (for instance, with a thickness in the range of about 50 microns to about 250 microns thick), flexible, and electrically insulating polymeric material sheet such as an inexpensive prepreg material commonly used in printed circuit boards which meets cell process integration and reliability requirements. The partially-processed back-contact, back-junction (IBC) backplane-attached solar cell (for instance, with a solar cell area of about 100 mm x 100 mm, 125 mm x 125 mm, 156 mm x 156 mm, 210 mm x 210 mm or larger, or solar cell area in the range of about 100 cm^2 to 100's of cm^2 and even larger) is then separated and lifted off (released) from the reusable template along the mechanically-weakened sacrificial porous silicon layer (for example through a Mechanical Release or MR lift-off process, breaking off the higher porosity porous

silicon interface to enable lift-off release) and the template may be conditioned (e.g., cleaned) and re-used multiple times (for instance, between about 10 and 100 times) to reduce the overall solar cell manufacturing cost. The remaining post-lift-off solar cell processing may then be performed on the backplane-attached solar cell, for example first on the solar cell sunny-side (or frontside) which is exposed after being lifted off and released from the template. Solar cell frontside or sunny-side processing may include, for instance, completing frontside texturization (for instance, using an alkaline or acitic texturing), post-texture surface preparation (cleaning), and formation of the frontside passivation and an anti-reflection coating (ARC) using a deposition process. The frontside passivation and ARC layer may be deposited using a Plasma-Enhanced Chemical-Vapor Deposition (PECVD) process and/or another suitable processing method.

[095] The monolithically isled cell (icell) structures and methods disclosed herein may be integrated into device fabrication, such as the exemplary disclosed solar cell fabrication process flow, without substantially altering or adding manufacturing process steps or tools and thus without substantially adding to the cost of manufacturing the solar cell and without substantially altering the main solar cell manufacturing process flow. In fact, the monolithically isled cell (icell) structures and methods disclosed herein can reduce the cost of manufacturing the solar cell, for instance, by reducing the metallization cost (using less metallization material and lower cost metallization process) and/or by improving the solar cell and module manufacturing yield (due to substantial mitigation of solar cell micro-cracks or breakage).

[096] In one embodiment, scribing (also known as trenching or cutting or dicing), of the master cell semiconductor substrate to form the internal isle partitioning trench boundaries and creating the plurality of trench-partitioned isles or mini-cells or sub-cells or tiles may be performed from the frontside or sunnyside (after lift-off release of the backplane-attached epitaxial silicon substrate layer), using a suitable method such as pulsed laser ablation (for instance, pulsed nanoseconds laser scribing) or a mechanical scribing method or a plasma scribing method, through the master cell silicon substrate layer thickness (for example, the epitaxial silicon layer thickness may be in the range of about a few microns up to about 100 μm). Pulsed laser ablation scribing (or another

suitable trench scribing method as described before) may be performed such that scribing through the thickness of the semiconductor substrate layer forms relatively narrow (e.g., width of less than 100 microns) trench isolation borders all the way through the entire thickness of the thin silicon layer and essentially stops at/on the backplane (removal and scribing of the continuous backplane material layer being rather small or negligible) - thus monolithically producing fully partitioned monolithic isles (or sub-cells or mini-cells or tiles) supported on a continuous backplane layer. Partitioning trench formation methods to form the plurality of isles and their associated trench partitioning boundaries in a master cell substrate having a thickness in the range of about a few microns to as large as about 200 microns (master cell substrate thickness or width shown as W in **Figs. 2**) include, for example: pulsed laser scribing (or dicing, or trenching), such as by pulsed nanoseconds laser ablation (using a suitable laser wavelength such as UV, green, IR, etc.); ultrasonic scribing or dicing; mechanical trench formation such as by using a mechanical saw or blade; patterned chemical etching (both wet and plasma etching); screen printing of an etch paste following by etching activation and rinsing of the etch paste residue, or any combination of known or the above mentioned trench formation methods. Pulsed laser ablation processing for trench formation may provide several advantages allowing for the direct patterning of the isle or mini-cell boundaries with relatively high process throughput, enabling formation of relatively narrow trenches (e.g., less than about 100 microns trench width), and without any process consumable (hence, very low process cost). However, irrespective of the trench formation method used to partition the plurality of isles or sub-cells, special care should be taken to reduce or minimize the trench width – for example, it may be desired to make the partitioning trench width less than about 100 microns, in order to make the solar cell area loss due to the icell partitioning trenches a relatively small to negligible fraction of the total icell area (for instance less than about 1% of the total icell area). This will ensure that the loss of icell total-area efficiency due to the partitioning trenches is rather negligible (e.g., less than 1% relative). Pulsed nanoseconds laser ablation processing is capable of high-throughput formation of trenches with trench width well below 100 microns (e.g., about 10 to 60 microns). For example, for a square-shaped icell with the master cell area of 156 mm x 156 mm and $4 \times 4 = 16$ isles (or mini-cells) and partitioning trenches with trench

width of 50 microns (0.05 mm), for example, formed by pulsed laser ablation trenching, the area fraction R of the total trench planar surface area A_{trench} to the total master cell area (or the icell area A_{icell}) can be calculated as follows: $R = A_{\text{trench}} / A_{\text{icell}} = 6 \times 156 \text{ mm} \times 0.05 \text{ mm} / (156 \text{ mm} \times 156 \text{ mm})$ or $R = 0.00192$. Therefore, this represents an area fraction R of 0.00192 or about 0.2%. This is an extremely small area fraction, ensuring negligible loss of total-area icell efficiency as a result of the partitioning trench areas. In reality, the loss of total-area icell efficiency would be smaller than 0.2% relative under these conditions, since the direct and/or diffused sunlight impinging on the trench isolation or partitioning areas can be at least partially and possibly mostly absorbed on the isle semiconductor edge regions and contribute to the photo-generation process.

[097] The monolithic isled (tiled) solar cell fabrication methods and structures described herein are applicable to various semiconductor (for example including but not limited to crystalline silicon, such as thin epitaxial silicon or thin crystalline silicon wafer) solar cells (for example, front contact or back contact solar cells of various designs with cell semiconductor absorber having a thickness in the range of about a few microns up to about 200 microns), including those formed using epitaxial silicon lift-off processing (as described earlier) or those formed using crystalline silicon wafers, such as mono-crystalline (CZ or MCZ or FZ) wafers or multi-crystalline wafers (cast or ribbon-grown wafers).

[098] For back-contact/back-junction square-shaped cells (for example high-efficiency back-contact/back-junction IBC cells formed using either epitaxial silicon lift-off processing or crystalline silicon wafer cells with backplane reinforcement), the master cell isles (also called tiles, pavers, sub-cells, or mini-cells) may be formed (for example, using pulsed nanoseconds laser scribing of crystalline silicon substrate) as an array of $N \times N$ square-shaped isles, $N \times M$ rectangular-shaped isles, K triangular-shaped isles, or any geometrically shaped isles or combination thereof on the shared master cell (icell) continuous backplane. In the case of solar cells fabricated using epitaxial lift-off processing, the isle partitioning trench formation process may occur immediately after the lift-off release of the partially-processed backplane-attached master cell and before the remaining processing steps such as frontside surface texturing and post-texture surface cleaning, or immediately after frontside texturing and post-texture surface cleaning and

before the process(es) to form the front-surface passivation and anti-reflection coating (ARC) layer(s). Performing the process to form the partitioning or isolation trenches (i.e., trenching process) by pulsed laser scribing or another suitable method (such as one of the other methods described earlier including but not limited to mechanical dicing) before the wet etch texture process (to form the solar cell frontside texture for reduced optical reflection losses) has an added advantage of removing any trenching-process-induced silicon edge damage through wet etching and removal of damaged silicon during the wet texture etch process (which also etches several microns of silicon, including any damaged silicon in the partitioning trench sidewalls, during the texture etch process).

[099] In some solar cell processing embodiments, including those representative process flows described in detail herein, no additional separate fabrication process equipment may be needed for the formation of the monolithically isled master cells (icells). In other words, the formation of trench-partitioned mini-cells or isles within each icell may be integrated fairly easily and seamlessly in solar cell fabrication methods. And in some cases, the monolithic isled solar cell (icell) fabrication process may improve the solar cell fabrication process flow through a reduction of solar cell manufacturing cost, for example, by reducing the cost of solar cell metallization, such as, for instance, by eliminating the need for a copper plating process and associated manufacturing equipment and facilities requirements for copper plating.

[0100] **Fig. 5A** is a representative backplane-attached icell manufacturing process flow based on epitaxial silicon and porous silicon lift-off processing. This process flow is for fabrication of backplane-attached, back-contact / back-junction solar cells (icells) using two patterned layers of solar cell metallization (M1 and M2). This example is shown for a solar cell with selective emitter, i.e., a main patterned field emitter with lighter emitter doping formed using a lighter boron-doped silicate glass (first BSG layer with smaller boron doping deposited by Tool 3), and more heavily-boron-doped emitter contact regions using a more heavily boron-doped silicate glass (second BSG layer with larger boron doping deposited by Tool 5). While this example is shown for an IBC solar cell using a double-BSG selective emitter process, the icell designs are applicable to a wide range of other solar cell structures and process flows, including but not limited to the IBC solar cells without selective emitter (i.e., same emitter boron doping in the field emitter

and emitter contact regions). This example is shown for an IBC icell with an n-type base and p-type emitter. However, the polarities can be changed so that the solar cell has p-type base and n-type emitter instead.

[0101] **Fig. 5A** is a representative manufacturing process flow embodiment for the fabrication of back-contact back-junction crystalline monolithic isled silicon solar cells (icells). Specifically, **Fig. 5A** provides for the formation of an epitaxial (epi) solar cell, optionally with a monolithically integrated bypass switch (MIBS) pn junction diode, and having a double borosilicate glass (BSG) selective emitter. As shown in this flow, mini-cell trench isolation regions are formed at Tool 13, after cell release border scribe and cell lift-off release and before texturization of the exposed released side (also known as frontside or sunnyside of the resulting icell). Alternatively, the mini-cell trench isolation regions may be formed after texture and post texture clean in Tool 14, and before frontside passivation (shown as PECVD). Performing the pulsed laser scribing before wet etch texture (texture and post texture clean using Tool 14) may have an added advantage of removing any laser-induced scribed silicon edge damage through wet etching and removal of damaged silicon.

[0102] A representative process flow for forming a monolithic isled (tiled) back-contact/back-junction (IBC) solar cell using epitaxial silicon lift-off processing may comprise the following fabrication steps: 1) start with reusable crystalline (mono-crystalline or multi-crystalline) silicon template; 2) form porous silicon on template (for example, bilayer porous silicon with a lower porosity surface layer and a higher porosity buried layer using anodic etch in HF/IPA or HF/acetic acid); 3) deposit epitaxial silicon with *in-situ* doping (for instance, n-type phosphorus doped epitaxial silicon); 4) perform back-contact/back-junction cell processing while the epitaxial silicon substrate resides on its template, including formation of patterned field emitter junction, backside passivation, doped base and emitter contact regions for subsequent metallized solar cell ohmic contacts, and formation of a first metallization layer (also known as M1) - see **Fig. 5A** for an example of a back-contact/back-junction (IBC) solar cell fabrication process flow comprising a selective emitter process (with more lightly doped field emitter and more heavily doped emitter contact regions) using double-BSG (BSG is boron-doped silicate glass or boron doped silicon oxide layer formed, for instance, by an atmospheric-pressure

chemical-vapor deposition or APCVD process) process flow for selective emitter formation (other methods of selective emitter formation may be used instead of double BSG process, for instance, using screen printed dopant pastes); 5) attach or laminate backplane layer or sheet on back-contact cell backside; 6) laser scribe release border (lift off release boundary) around the backplane boundary at least partially into epitaxial silicon layer thickness and then release by a lift-off process (e.g., mechanical release lift-off to separate the backplane-attached epitaxial silicon substrate from the reusable template by breaking off the mechanically weakened higher porosity porous silicon layer); 7) perform the trenching (also called scribing or cutting or dicing) process using pulsed nanoseconds laser ablation (or one of the other suitable trench isolation formation methods as described earlier) from the solar cell sunnyside (opposite the backplane side) to monolithically partition the silicon substrate into the plurality of mini-cells or isles – for instance, into an array of isles comprising $4 \times 4 = 16$ mini-cells (also optionally trim the master cell peripheral boundary, for instance, using pulsed laser cutting, to establish the precise master cell or icell dimensions with well-defined smooth cell boundary edges); 8) proceed with performing the remaining back-end fabrication processes such as: wet silicon etch/texture in alkaline and/or acidic chemistry (this process performs the texturization on the frontside while the chemically-resistant backplane protects the backside of the solar cell from the texturization chemistry), post-texture surface preparation including wet cleaning (this process performs the frontside surface cleaning while the chemically-resistant backplane protects the backside of the solar cell from the wet cleaning chemistry), deposition of the frontside surface passivation and anti-reflection coating (ARC) layer(s), for instance, by Plasma-Enhanced Chemical-Vapor Deposition (PECVD) or a combination of PECVD for ARC deposition (e.g., hydrogenated silicon nitride) with another process such as Atomic Layer Deposition (ALD) for passivation layer deposition (such as a thin sub-30 nm layer of aluminum oxide, amorphous silicon, or amorphous silicon oxide directly on the cleaned, textured silicon surface and underneath the silicon nitride ARC layer – if using a multi-layer frontside passivation / ARC structure, such as a two-layer structure of one of the above-mentioned passivation layers covered by the silicon nitride ARC layer, the entire stack may also be deposited using PECVD using a vacuum-integrated process). The frontside

passivation and ARC layer deposition will not only cover the frontside surfaces of the mini-cells or isles, it will also cover the sidewalls of the trench-partitioned isles or mini-cells, hence, substantially improving the passivation and ARC properties of the icell by improving the passivation and light capturing properties of the trench sidewalls as well as the top surfaces of the isles. After completion of the frontside texture / cleaning / passivation and ARC deposition processes, the remaining solar cell fabrication process step involves completion of the second metallization layer (M2) on the backplane-attached solar cell backside. In order to accomplish this task, a plurality of via holes are drilled according to a pre-designed via hole pattern, for instance using laser drilling, into the thin (e.g., 25 microns up to 250 microns backplane thickness), electrically insulating, continuous backplane layer (e.g., a 25 micron to 100 micron thick laminated prepreg sheet). The number of via holes on a solar cell (e.g., 156 mm x 156 mm icell) backplane may be on the order of 100's to 1000's. The via holes may have average diagonal hole dimension (e.g., average diameter of each via hole) in the range of 10's of microns to 100's of microns (for instance, about 100 microns to 300 microns). The laser-drilled via holes through the electrically insulating backplane layer are positioned to land on the interdigitated base and emitter metallization fingers (formed by the first level of patterned metallization by screen printing of a metallic paste or by physical-vapor deposition and patterning of a metal layer such as a metal comprising aluminum or aluminum-silicon alloy). These via holes will serve as the interconnection channels or plugs between the first layer of patterned metallization or M1 formed directly on the solar cell backside prior to the backplane attachment / lamination and the second layer of patterned metal or M2 to be formed immediately after formation of the laser-drilled via holes. In some instances for the icells disclosed herein, the second level of patterned metallization M2 may be formed by one of several methods, including but not limited to one or a combination of: (1) Physical-Vapor Deposition or PVD (thermal evaporation and/or electron-beam evaporation and/or plasma sputtering) of an inexpensive high-conductivity metal comprising, for instance, aluminum and/or copper (other metals may also be used) followed by pulsed laser ablation patterning, (2) Physical-Vapor Deposition or PVD (thermal evaporation and/or electron-beam evaporation and/or plasma sputtering) of an inexpensive high-conductivity metal comprising, for instance, aluminum and/or copper

(other metals may also be used) followed by metal etch patterning (e.g. screen printing of an etch paste or screen printing of a resist followed by a metal wet etch process and subsequent removal of the resist), (3) Screen printing or stencil printing of a suitable metal paste (such as a paste comprising copper and/or aluminum), (4) Inkjet printing or aerosol printing of a suitable metal paste (such as a paste comprising copper and/or aluminum), (5) Patterned plating of a suitable metal, for instance, copper plating. The patterned second layer of metallization (M2) may also comprise a thin capping layer (for instance, a thin <1 micron capping layer of NiV or Ni formed by plasma sputtering or screen printing or plating) to protect the main patterned M2 (e.g., aluminum and/or copper containing high conductivity metal) and to provide a suitable surface for soldering or conductive adhesive as needed. The back-contact / back-junction (IBC) solar cells described herein may utilize two layers of patterned metallization (M1 and M2), with the first patterned metallization layer M1 forming the interdigitated base and emitter metallization fingers on each mini-cell or isle according to a fine-pitch pattern (for instance, base-emitter M1 finger pitch in the range of about 200 microns to 2 mm, and in some cases in the range of about 500 microns to about 1 mm), and the second patterned layer of metallization M2 forming the final icell metallization and interconnecting the isles or mini-cells according to a pre-specified current and voltage scaling factor. Patterned M2 may be patterned substantially orthogonal or perpendicular to patterned M1 and have a much larger finger-to-finger pitch than patterned M1 fingers. This will substantially facilitate fabrication of patterned M2 according to a low-cost, high-yield manufacturing process. Patterned M2 not only formed the final icell patterned metallization, it also forms the electrically conductive via plugs through the laser-drilled via holes in order to complete the M2-to-M1 interconnections based on desired icell metallization structure.

[0103] It is also possible to extend the icell concept so that the second layer of patterned metallization M2 can be used to not only complete the individual master cell (or icell) electrical interconnections, but also monolithically interconnect a plurality of icells sharing the same continuous backplane layer, hence, resulting in a Monolithic Module structure facilitated and enabled by the icells embodiments and with numerous additional benefits. Figure 5A for epitaxial silicon lift off icell representative embodiment shows the

process flow for fabricating monolithic icells with each icell being attached to its own separate pre-cut continuous backplane layer, and each individual backplane attached icell being processed through the entire backend process flow after its backplane lamination. The icells processed using this approach will then be tested and sorted at the end of the process and can be assembled into the PV modules by interconnections of the icells to one another, for instance in electrical series, using tabbing and/or stringing of the cells (also involving soldering and/or conductive adhesives to interconnect the plurality of solar cells to one another as part of PV module assembly), and then completion of the module lamination and final module assembly and testing. With reference to Figure 5A for epitaxial silicon lift off icell representative embodiment, an alternative embodiment of an icell implementation resulting in a novel monolithic module structure involves attachment or lamination of a plurality of relatively closely-spaced icells (for instance, with the adjacent icell to icell spacing in the range of 50 microns up to about 2 mm, and often in the range of about 100 microns to 1 mm) on their backsides to a larger continuous backplane sheet at the Backplane Lamination (or attachment step) performed by Tool 12. The remaining process steps after Tool 12 are performed concurrently on the plurality of icells sharing a common continuous backplane layer on their backsides (instead of being performed on the individual separate icells, each with their own separate backplane). After completion of the final metallization (patterned second layer of metal M2), the monolithic patterned M2 not only completes the metallization pattern for each icell among the plurality of the icells sharing the larger continuous backplane layer, it also completes electrical interconnections of the plurality of icells to one another according to any desired arrangement, for instance, interconnecting the icells to one another all in series or in a hybrid parallel / series arrangement. This embodiment enables fabrication of icells and the monolithic electrical interconnections among a plurality of icells on a shared continuous backplane layer, hence eliminating the need for subsequent soldering / tabbing / stringing of the icells to one another during the final module assembly. For example, in order to make $6 \times 10 = 60$ -cell modules, an array of $6 \times 10 = 60$ icells are attached / laminated on their backsides immediately after completion of the patterned first layer of metal (M1) – after Tool 11 process in Figure 5A - to a properly sized continuous backplane sheet (e.g., a sheet of prepreg) and the remaining process

steps (starting with the backplane lamination / attachment process shown as Tool 12 and through the remaining backend process steps through completion of the second layer of patterned metal M2) are all performed on the large backplane-attached sheet comprising the plurality of (e.g., $6 \times 10 = 60$) icells. In this monolithic module example which comprises $6 \times 10 = 60$ icells, if each icell has dimensions of about 156 mm x 156 mm and the spacing between the adjacent icells is about 1 mm, the continuous backplane layer or sheet (e.g., an aramid fiber / resin prepreg sheet with a thickness in the range of about 50 to 100 microns) to be used for attachment / lamination to the backsides of the 6×10 array of icells should have minimum dimensions of about 942 mm x 1570 mm (e.g., the sheet may be made somewhat oversized to allow for backplane extensions in the side margins of the monolithic module, for instance, about 1 m x 1.6 m backplane sheet dimensions in this $6 \times 10 = 60$ icell monolithic module example). As another example, in order to make $6 \times 12 = 72$ -cell modules, an array of $6 \times 12 = 72$ icells are attached / laminated on their backsides immediately after completion of the patterned first layer of metal (M1) – after Tool 11 process in Figure 5A - to a properly sized continuous backplane sheet (e.g., a sheet of prepreg) and the remaining process steps (starting with the backplane lamination / attachment process shown as Tool 12 and through the remaining backend process steps through completion of the second layer of patterned metal M2) are all performed on the large backplane-attached sheet comprising the plurality of (e.g., $6 \times 12 = 72$) icells. In this monolithic module example which comprises $6 \times 12 = 72$ icells, if each icell has dimensions of about 156 mm x 156 mm and the spacing between the adjacent icells is about 1 mm, the continuous backplane layer or sheet (e.g., an aramid fiber / resin prepreg sheet with a thickness in the range of about 50 to 100 microns) to be used for attachment / lamination to the backsides of the 6×12 array of icells should have minimum dimensions of about 942 mm x 1884 mm (e.g., the sheet may be made somewhat oversized to allow for backplane extensions in the side margins of the monolithic module, for instance, approximately 1 m x 1.9 m backplane sheet dimensions in this $6 \times 12 = 72$ icell monolithic module example). The monolithic interconnections of the plurality of icells on a shared continuous backplane layer using the second layer of patterned metal M2 results in further reduction of the overall solar cell and PV module manufacturing cost as well as

improved projected reliability of the PV modules during field operation (due to the elimination of soldered tabs, strings).

[0104] The embodiments of this invention can be applied to solar cells using this type of process flow as outlined in the representative process flow of Figure 5A, as well as many other solar cell designs (as described before) and solar cell fabrication process flows including but not limited to the solar cells fabricated from starting monocrystalline wafers (e.g., Czochralski or CZ, Float Zone or FZ) or multi-crystalline wafers (from cast crystalline bricks or formed by a ribbon pulling process) or epitaxial growth or other substrate fabrication methods. Moreover, icell embodiments may be applied to other semiconductor materials besides silicon as described before, including but not limited to gallium arsenide, germanium, gallium nitride, other compound semiconductors, or a combination thereof.

[0105] **Fig. 5B** is a high level solar cell and module fabrication process flow embodiment using starting crystalline (mono-crystalline or multi-crystalline) silicon wafers. **Fig. 5B** shows a high-level icell process flow for fabrication of backplane-attached back-contact/back-junction (IBC) icells using two layers of metallization: M1 and M2. The first layer or level of patterned cell metallization M1 is formed as essentially the last process step among a plurality of front-end cell fab processes prior to the backplane lamination to the partially processed icell (or a larger continuous backplane attached to a plurality of partially processed icells when fabricating monolithic modules as described earlier). The front-end cell fab processes outlined in the top 4 boxes of Fig. 5B essentially complete the back-contact/back-junction solar cell backside structure through the patterned M1 layer. Patterned M1 is designed to conform to the icell isles (mini-cells) and comprises a fine-pitch interdigitated metallization pattern as described for the epitaxial silicon icell process flow outlined in **Fig. 5A**. In **Fig. 5B**, the fifth box from the top involves attachment or lamination of the backplane layer or sheet to the partially processed icell backside (or to the backsides of a plurality of partially processed icells when making a monolithic module) – this process step is essentially equivalent to the one performed by Tool 12 in **Fig. 5A** in case of epitaxial silicon lift-off process). In **Fig. 5B**, the sixth and seventh boxes from the top outline the back-end or post-backplane-attachment (also called post-lamination) cell fab processes to complete the remaining

frontside (optional silicon wafer thinning etch to form thinner silicon absorber layer if desired, partitioning trenches, texturization, post-texturization cleaning, passivation and ARC) as well as the via holes and second level or layer of patterned metallization M2. The “post-lamination” processes (or the back-end cell fab processes performed after the backplane attachment) outlined in the sixth and seventh boxes of **Fig. 5B** essentially correspond to the processes performed by Tools 13 through 18 for the epitaxial silicon lift off process flow shown in **Fig. 5A**. The bottom box in **Fig. 5B** describes the final assembly of the resulting icells into either flexible, lightweight PV modules or into rigid glass-covered PV modules. If the process flow results in a monolithic module comprising a plurality of icells monolithically interconnected together by the patterned M2 (as described earlier for the epitaxial silicon lift off process flow), the remaining PV module fabrication process outlined in the bottom box of **Fig. 5B** would be simplified since the plurality of the interconnected icells sharing a larger continuous backplane and the patterned M2 metallization for cell-to-cell interconnections are already electrically interconnected and there is no need for tabbing and/or stringing and/or soldering of the solar cells to one another. The resulting monolithic module can be laminated into either a flexible, lightweight PV module (for instance, using a thin flexible fluoropolymer cover sheet such as ETFE or PFE on the frontside instead of rigid / heavy glass cover sheet) or a rigid, glass-covered PV module.

[0106] Fig. 5C illustrates an alternative high level solar cell (icell) and module fabrication process flow embodiment using epitaxial silicon and porous silicon lift-off processing as compared to the process flow of **Fig. 5A**. **Fig. 5C** also shows a high-level icell process flow for fabrication of backplane-attached back-contact/back-junction (IBC) icells using two layers of metallization: M1 and M2. The first layer or level of patterned cell metallization M1 is formed as essentially the last process step among a plurality of front-end cell fab processes prior to the backplane lamination to the partially processed icell using epitaxial silicon as the solar cell absorber (or a larger continuous backplane attached to a plurality of partially processed epitaxial icells after lift-off release of the individual partially processed icells, when fabricating monolithic modules as described earlier). The front-end cell fab processes outlined in the top 4 boxes of **Fig. 5C** essentially complete the back-contact/back-junction solar cell backside structure through

the patterned M1 layer. Patterned M1 is designed to conform to the icell isles (mini-cells) and comprises a fine-pitch interdigitated metallization pattern as described for the epitaxial silicon icell process flow outlined in Fig. 5A. In Fig. 5C, the fifth box from the top involves attachment or lamination of the backplane layer or sheet to the partially processed epitaxial icell backside (or using a larger continuous backplane sheet to be attached to the backsides of a plurality of partially processed and released icells when making a monolithic module) – this process step is essentially equivalent to the one performed by Tool 12 in **Fig. 5A** in case of the earlier epitaxial silicon lift-off process flow). In **Fig. 5C**, the sixth and seventh boxes from the top outline the back-end or post-backplane-attachment (also called post-lamination) cell fab processes to complete the remaining frontside (icell partitioning trenches, texturization, post-texturization cleaning, passivation and ARC) as well as the via holes and second level or layer of patterned metallization M2. The “post-lamination” processes (or the back-end cell fab processes performed after the backplane attachment) outlined in the sixth and seventh boxes of Fig. 5C essentially correspond to the processes performed by Tools 13 through 18 for the epitaxial silicon lift off process flow shown in **Fig. 5A**. The bottom box in **Fig. 5C** describes the final assembly of the resulting icells into either flexible, lightweight PV modules or into rigid glass-covered PV modules. If the process flow results in a monolithic module comprising a plurality of icells monolithically interconnected together by the patterned M2 (as described earlier for the epitaxial silicon lift off process flow), the remaining PV module fabrication process outlined in the bottom box of **Fig. 5C** would be simplified since the plurality of the interconnected icells sharing a larger continuous backplane and the patterned M2 metallization for cell-to-cell interconnections are already electrically interconnected and there is no need for tabbing and/or stringing and/or soldering of the solar cells to one another. The resulting monolithic module can be laminated into either a flexible, lightweight PV module (for instance, using a thin flexible fluoropolymer cover sheet such as ETFE or PFE on the frontside instead of rigid / heavy glass cover sheet) or a rigid, glass-covered PV module.

[0107] Fig. 5D is a high level cross-sectional device diagram showing an expanded and selective simplified view of a mini-cell or isle among a plurality of isles in an icell after solar cell fabrication steps of an interdigitated back-contact (IBC) solar cell embodiment.

Detailed doped emitter and base regions, optional front-surface field (FSF) and/or optional back-surface field (BSF) regions, contacts for M1 metallization, and conductive via plugs connecting patterned M1 to patterned M2 through the electrically-insulating continuous backplane layer are not shown.

[0108] Fig. 5E is a more detailed cross-sectional diagram showing an expanded view of a mini-cell or isle among a plurality of isles in an icell after solar cell fabrication steps of an interdigitated back-contact (IBC) solar cell embodiment. These cross-sectional diagrams are provided as descriptive embodiments to further detail cell architectures which may be used in accordance with the disclosed subject matter.

[0109] In practice, the isolation trenches partitioning the main initially continuous semiconductor substrate through the substrate layer thickness (either from a starting crystalline semiconductor wafer or from an epitaxially grown crystalline layer) into a plurality of mini-cells (or isles or sub-cells or tiles) on the continuous supporting backplane layer have average trench width which may be on the order of about 10's of microns (or in the range of about 10 microns to about 100 microns). As described earlier, trench isolation regions partitioning the backplane-attached semiconductor layer into a plurality of mini-cells (or isles or sub-cells or tiles) may be formed by using either pulsed laser ablation / scribing or another technique, for instance, by mechanical dicing / scribing or ultrasonic dicing / scribing or water jet dicing / scribing or another method (the terms scribing, dicing, cutting, and ablation are used interchangeably herein when describing the icell partitioning or isolation trench formation process; moreover, the terms partitioning trenches or isolation trenches are used interchangeably in this document when referring to the trench pattern formed through the semiconductor layer thickness to form a plurality of isles or mini-cells, all supported by and attached to a continuous backplane layer or sheet which is attached to the partially processed semiconductor substrate prior to the partitioning trench formation process). A suitable trench partitioning or isolation formation process such as a pulsed laser scribing or cutting process selectively cuts through the semiconductor layer and effectively stops on the backplane layer or sheet after cutting essentially through the entire thickness of the semiconductor layer without a substantial removal of the backplane material (hence, negligible or relatively small trenching of the backplane layer to maintain the integrity of

the continuous backplane sheet). For instance, the partitioning trench formation process, such as a pulsed nanoseconds ablation scribing process, can be performed to form the desired partitioning trench pattern by cutting through the semiconductor layer thickness based on the desired trench pattern, while limiting the backplane sheet material removal to relatively small range between zero and less than a fraction of the backplane layer thickness (e.g., backplane material trenching depth limited to between zero and less than about 20% of the backplane layer thickness). This will ensure the overall mechanical, physical, and electrical integrity of the monolithic icell (or the monolithic module in the case of fabricating monolithic modules using a plurality of icells attached to a shared backplane sheet).

[0110] The methods and structures described herein provide for a master monolithic cell (icell) comprising trench-partitioned or trench-isolated isles (also referred to as tiles, pavers, sub-cells, or mini-cells). And while a common master monolithic cell (icell) shape is a square, the master cell (icell) may be chosen to have any desired geometrical shapes and dimensions, for example a full square, pseudo square, rectangle, pseudo-rectangle, parallelogram, hexagon, triangle, any polygon, circle, ellipse, or a combination thereof. The most common shapes used for crystalline silicon solar cells and modules are the full-square and pseudo-square solar cells. Furthermore, the trench-partitioned isles may be formed of various and individually different geometrical shapes and/or sizes (areas and side / diagonal dimensions), or may be uniformly sized and shaped (in other words uniformly sized and shaped isles having the same geometrical shapes and areas as one another). One consideration determining the shapes and sizes of the isles making up the solar cell is the desired degree of backplane-attached solar cell flexibility or bendability and pliability (when using a flexible backplane sheet such as a prepreg sheet) while minimizing or eliminating crack generation or crack propagation in resulting solar cell comprising the semiconductor absorber layer and in the solar cell metallization structure. In some instances, it may be desired to position relatively smaller isles (for example smaller triangular shaped or square shaped isles) proximate the master cell (icell) edge regions and relatively larger isles (for example square shaped) proximate the master cell (icell) center region (or the region away from the icell edges) since the solar cell edges may be more susceptible to crack formation and propagation during and after

cell processing, during module lamination, and also during the field operation of the resulting PV modules. In other instances, and depending on the isle electrical connection design, the isles (or a subgroup of isles connected in electrical parallel arrangement) may have a uniform shape to produce uniform current under uniform illumination. Importantly, any number of isle shapes and/or sizes may be used dependent on other considerations such as master cell (icell) flexibility / bendability and isle-to-isle electrical interconnection designs to produce the desired icell voltage and current scaling factor.

[0111] For a square-shaped or rectangular-shaped master cell (icell) having an array of square-shaped or rectangular-shaped isles attached to a shared continuous backplane, the isles may be an $N \times N$ array where N is an integer with $N \geq 2$ (for example $N \times N$ is greater than or equal to four, or in other words there are at least four isles in an icell). In general, an icell may have as few as 2 isles or subcells (e.g., a square-shaped icell with 2 sub-cells or isles may have two triangular isles). The icell configurations with $N \times N$ isles present the advantage of simplicity in terms of the icell processing and interconnection design, as well as good compatibility with full-square and pseudo-square solar cells. Alternatively, the isles may be in an $N \times M$ array where N and M are both integers (for example $N \times M$ is greater than or equal to 2, in other words there are at least two isles). Using a flexible continuous (or continuous) backplane, the degree of icell flexibility or bendability or pliability may be increased for larger values of $N \times N$ or $N \times M$, and/or by using relatively smaller sized isles near the cell edge regions (compared to the isles away from the edge regions). For example, for a 156 mm x 156 mm square-shaped or pseudo-square shaped icell, an icell with $4 \times 4 = 16$ isles (e.g., uniform area isles) will be more flexible or bendable than an icell with $3 \times 3 = 9$ isles (e.g., uniform area isles). Improved flexibility / bendability of icells are desirable attributes for flexible, lightweight PV modules. And while the number of isles in any shape may be increased or decreased depending on desired master cell flexibility or bendability or pliability, the removal of semiconductor material to form the partitioning trenches and corresponding increased cell edge area (total trench sidewall areas of the isles or mini-cells) should be limited, for example to no more than about 2% of the master cell (icell) area (the ratio R as discussed earlier in this document), and in some cases to less than 1% of the icell area.

[0112] In some instances, it may be desirable to increase cell pliability by shaping isles (tiles, mini-cells), for instance into certain geometrically shaped mini-cells such as triangular-shaped isles (mini-cells). For example, to enhanced cell flexibility or pliability in various bending directions (e.g., along X, Y, and diagonal axes) for a square-shaped or rectangular-shaped master cell (icell), the isles may be an array of triangles, or a combination of squares (and/or rectangles) and triangles (in some embodiments, square-shaped isles proximate the master cell center region and triangular isles proximate the cell edge regions). Importantly, various combinations of isle shapes and arrangements within the master cell (icell) may be formed in accordance with the disclosed subject matter.

[0113] **Figs. 6A** and **6B** are diagrams of backplane-attached solar cell (icell) embodiments showing arrays of uniform square shaped mini-cells (i.e., isles or mini-cells all having essentially the same areas). **Fig. 6A** is a representative schematic plan view (frontside or sunnyside view) diagram of an icell pattern (shown for square-shaped isles and square-shaped icell) along with uniform-size (equal-size) square-shaped isles for $N \times N = 3 \times 3 = 9$ isles (or sub-cells, mini-cells, tiles). This schematic diagram shows a plurality of isles (shown as $3 \times 3 = 9$ isles) partitioned by trench isolation regions. **Fig. 6B** is a representative schematic plan view (frontside or sunnyside view) diagram of an icell pattern (shown for square-shaped isles and square-shaped icell) along with uniform-size (equal-size) square-shaped isles for $N \times N = 5 \times 5 = 25$ isles (or sub-cells, mini-cells, tiles). This schematic diagram shows a plurality of isles (shown as $5 \times 5 = 25$ isles) partitioned by trench isolation regions.

[0114] **Fig. 6A** is a schematic diagram of a top or plan view of a 3×3 uniform isled (tiled) master solar cell or icell **30** defined by cell peripheral boundary or edge region **32**, having a side length **L**, and comprising nine (9) uniform square-shaped isles formed from the same original continuous substrate and identified as I_{11} through I_{33} attached to a continuous (continuous) backplane on the master cell backside (backplane and solar cell backside not shown). Each isle or sub-cell or mini-cell or tile is defined by an internal isle peripheral boundary (for example, an isolation trench cut through the master cell semiconductor substrate thickness and having a trench width substantially smaller than the isle side dimension, with the trench width no more than 100's of microns and often

less than or equal to about 100 μm – for instance, a few up to about 100 μm) shown as trench isolation or isle partitioning borders **34**. Main cell (or icell) peripheral boundary or edge region **32** has a total peripheral length of $4L$; however, the total icell edge boundary length comprising the peripheral dimensions of all the isles comprises cell peripheral boundary **32** (also referred to as cell outer periphery) and trench isolation borders **34**. Thus, for an icell comprising $N \times N$ isles or mini-cells in a square-shaped isle embodiment, the total icell edge length is $N \times$ cell outer periphery. In the representative example of **Fig. 6A** showing an icell with $3 \times 3 = 9$ isles, $N = 3$, so total cell edge length is $3 \times$ cell outer periphery $4L = 12L$ (hence, this icell has a peripheral dimension which is 3 times larger than that of the standard prior art cell shown in **Fig. 1**). For a square-shaped master cell or icell with dimensions 156 mm x 156 mm, square isle side dimensions are approximately 52 mm x 52 mm and each isle or sub-cell has an area of 27.04 cm^2 per isle.

[0115] Fig. 6B is a schematic diagram of a top or plan view of a 5×5 uniform isled (tiled) master solar cell or icell **40** defined by cell peripheral boundary or edge region **42**, having a side length L , and comprising twenty five (25) uniform square-shaped isles formed from the same original continuous substrate and identified as I_{11} through I_{55} attached to a continuous (continuous) backplane on the master cell backside (backplane and solar cell backside not shown). Each isle or sub-cell or mini-cell or tile is defined by an internal isle peripheral boundary (for example, an isolation trench cut through the master cell semiconductor substrate thickness and having a trench width substantially smaller than the isle side dimension, with the trench width no more than 100's of microns and often less than or equal to about 100 μm – for instance, a few up to about 100 μm) shown as trench isolation or isle partitioning borders **44**. Main cell (or icell) peripheral boundary or edge region **42** has a total peripheral length of $4L$; however, the total icell edge boundary length comprising the peripheral dimensions of all the isles comprises cell peripheral boundary **42** (also referred to as cell outer periphery) and trench isolation borders **44**. Thus, for an icell comprising $N \times N$ isles or mini-cells in a square-shaped isle embodiment, the total icell edge length is $N \times$ cell outer periphery. In the representative example of **Fig. 6B** showing an icell with $5 \times 5 = 25$ isles, $N = 5$, so total cell edge length is $5 \times$ cell outer periphery $4L = 20L$ (hence, this icell has a peripheral dimension which is

5 times larger than that of the standard prior art cell shown in **Fig. 1**). For a square-shaped master cell or icell with dimensions 156 mm x 156 mm, square isle side dimensions are approximately 31.2 mm x 31.2 mm and each isle or sub-cell has an area of 9.73 cm² per isle. . In some instances when balanced with other considerations, it may be desired to keep total cell edge length (cumulative lengths of the sidewall edges of all the isles in an icell) to 24L (for example in a 6 X 6 array) in order to limit the total icell edge length and sidewall area.

[0116] Figs. 7A and 7E are representative plan view diagrams of solar cell embodiments (icells) with triangular shaped isles or mini-cells. **Fig. 7A** is a representative schematic plan view (frontside or sunnyside view) diagram of an icell pattern (shown for triangular-shaped isles and square-shaped icell) along with uniform-size (equal-size) triangular-shaped isles (or sub-cells, mini-cells, tiles) with $K = 2 \times 4 = 8$ triangular isles – a pair of triangular isles per square quadrant of the icell. This schematic diagram shows a plurality of isles (shown as $K = 2 \times 4 = 8$ isles) partitioned by trench isolation regions. **Fig. 7B** is a representative schematic plan view (frontside or sunnyside view) diagram of an icell pattern (shown for triangular-shaped isles and square-shaped icell) along with uniform-size (equal-size) triangular-shaped isles (or sub-cells, mini-cells, tiles) with $K = 2 \times 4 = 8$ triangular isles – a pair of triangular isles per square quadrant of the icell. This schematic diagram shows a plurality of isles (shown as $K = 2 \times 4 = 8$ isles) partitioned by trench isolation regions. The trench isolation pattern for the icell in **Fig. 7B** is slightly different than that in **Fig. 7A**. **Fig. 7C** is a representative schematic plan view (frontside or sunnyside view) diagram of an icell pattern (shown for triangular-shaped isles and square-shaped icell) along with uniform-size (equal-size) triangular-shaped isles (or sub-cells, mini-cells, tiles) with $K = 4 \times 4 = 16$ triangular isles – four triangular isles per square quadrant of the icell. This schematic diagram shows a plurality of isles (shown as $K = 4 \times 4 = 16$ isles) partitioned by trench isolation regions. The number of triangular isles (mini-cells) in this embodiment is twice the number of triangular isles (mini-cells) in the icell embodiments of **Fig. 7A** and **Fig. 7B**. **Fig. 7D** is a representative schematic plan view (frontside or sunnyside view) diagram of an icell pattern (shown for triangular-shaped isles and square-shaped icell) along with uniform-size (equal-size) triangular-shaped isles (or sub-cells, mini-cells, tiles) with $K = 4 \times 3 \times 3 = 36$ triangular isles – four

triangular isles per square quadrant of the icell. This schematic diagram shows a plurality of isles (shown as $K = 4 \times 3 \times 3 = 36$ isles) partitioned by trench isolation regions. The number of triangular isles (mini-cells) in this embodiment is 4.5 times the number of triangular isles (mini-cells) in the icell embodiments of **Fig. 7A** and **Fig. 7B**.

[0117] Fig. 7E is a representative schematic plan view (frontside or sunnyside view) diagram of an icell pattern (shown for triangular-shaped isles and square-shaped icell) along with uniform-size (equal-size) triangular-shaped isles (or sub-cells, mini-cells, tiles) with $K = 2 \times 4 \times 4 = 32$ triangular isles – eight triangular isles per square quadrant of the icell. This schematic diagram shows a plurality of isles (shown as $2 \times 4 \times 4 = 32$ isles) partitioned by trench isolation regions. The number of triangular isles (mini-cells) in this embodiment is 4 times the number of triangular isles (mini-cells) in the icell embodiments of **Fig. 7A** and **Fig. 7B**.

[0118] Fig. 7A is a diagram of a top view of uniform triangular-shaped isles in an isled master solar cell or icell **50** defined by cell peripheral boundary **52** and having a side length **L** and comprising eight uniform (equal areas) triangular-shaped isles I_1 through I_8 . Each isle or sub-cell or mini-cell or tile is defined by an internal isle peripheral boundary (for example, an isolation trench cut through the master cell semiconductor substrate thickness and having a trench width substantially smaller than the isle side dimension, with the trench width no more than 100's of microns and often less than or equal to about $100\ \mu\text{m}$ – for instance, a few up to about $100\ \mu\text{m}$) shown as trench isolation or isle partitioning borders **54**. Main cell (or icell) peripheral boundary or edge region **52** has a total peripheral length of $4L$; however, the total icell edge boundary length comprising the peripheral dimensions of all the isles comprises cell peripheral boundary **52** (also referred to as cell outer periphery) and trench isolation borders **54**. In the representative example of **Fig. 7A** showing an icell with $K = 2 \times 4 = 8$ triangular isles, $K = 8$, so total cell edge length is $3.4142 \times$ cell outer periphery $4L = 13.567L$ (hence, this icell has a peripheral dimension which is 3.4142 times larger than that of the standard prior art cell shown in **Fig. 1**). For a square-shaped master cell or icell with dimensions $156\ \text{mm} \times 156\ \text{mm}$, triangular isle side dimensions are approximately $78\ \text{mm} \times 78\ \text{mm}$ (for the two equal right-angle sides of the triangle) and each isle or sub-cell has an area of $30.42\ \text{cm}^2$ per isle.

[0119] **Fig. 7B** is a diagram of a top view of uniform triangular-shaped isles in an isled master solar cell or icell **60** defined by cell peripheral boundary **62** and having a side length **L** and comprising an alternative arrangement of eight uniform (equal areas) triangular-shaped isles I_1 through I_8 , as compared to the triangular isles or mini-cells pattern of Fig. 7A. Each isle or sub-cell or mini-cell or tile is defined by an internal isle peripheral boundary (for example, an isolation trench cut through the master cell semiconductor substrate thickness and having a trench width substantially smaller than the isle side dimension, with the trench width no more than 100's of microns and in some cases less than or equal to about $100\ \mu\text{m}$ – for instance, a few up to about $100\ \mu\text{m}$) shown as trench isolation or isle partitioning borders **64**. Main cell (or icell) peripheral boundary or edge region **62** has a total peripheral length of $4L$; however, the total icell edge boundary length comprising the peripheral dimensions of all the isles comprises cell peripheral boundary **62** (also referred to as cell outer periphery) and trench isolation borders **64**. In the representative example of **Fig. 7B** showing an icell with $K = 2 \times 4 = 8$ triangular isles, $K = 8$, so total cell edge length is $3.4142 \times$ cell outer periphery $4L = 13.567L$ (hence, this icell has a peripheral dimension which is 3.4142 times larger than that of the standard prior art cell shown in **Fig. 1**). For a square-shaped master cell or icell with dimensions $156\ \text{mm} \times 156\ \text{mm}$, triangular isle side dimensions are approximately $78\ \text{mm} \times 78\ \text{mm}$ (for the two equal right-angle sides of the triangle) and each isle or sub-cell has an area of $30.42\ \text{cm}^2$ per isle. .

[0120] **Fig. 7C** is a diagram of a top view of uniform triangular-shaped isles in an isled master solar cell or icell **70** defined by cell peripheral boundary **72** and having a side length **L** and comprising an arrangement of sixteen uniform (equal areas) triangular-shaped isles I_1 through I_{16} . Each isle or sub-cell or mini-cell or tile is defined by an internal isle peripheral boundary (for example, an isolation trench cut through the master cell semiconductor substrate thickness and having a trench width substantially smaller than the isle side dimension, with the trench width no more than 100's of microns and in some cases less than or equal to about $100\ \mu\text{m}$ – for instance, a few up to about $100\ \mu\text{m}$) shown as trench isolation or isle partitioning borders **74**. Main cell (or icell) peripheral boundary or edge region **72** has a total peripheral length of $4L$; however, the total icell edge boundary length comprising the peripheral dimensions of all the isles comprises cell

peripheral boundary **72** (also referred to as cell outer periphery) and trench isolation borders **74**. In the representative example of **Fig. 7C** showing an icell with $K = 4 \times 2 \times 2 = 16$ triangular isles, $K = 16$, so total cell edge length is $4.8284 \times$ cell outer periphery $4L = 19.313L$ (hence, this icell has a peripheral dimension which is 4.8284 times larger than that of the standard prior art cell shown in **Fig. 1**). For a square-shaped master cell or icell with dimensions $156 \text{ mm} \times 156 \text{ mm}$, each triangular isle or sub-cell in this embodiment has an area of 15.21 cm^2 per isle.

[0121] **Fig. 7D** is a diagram of a top view of uniform triangular-shaped isles in an isled master solar cell or icell **80** defined by cell peripheral boundary **82** and having a side length **L** and comprising an arrangement of sixteen uniform (equal areas) triangular-shaped isles I_1 through I_{16} . Each triangular isle or sub-cell or mini-cell or tile is defined by an internal isle peripheral boundary (for example, an isolation trench cut through the master cell semiconductor substrate thickness and having a trench width substantially smaller than the isle side dimension, with the trench width no more than 100's of microns and often less than or equal to about $100 \text{ }\mu\text{m}$ – for instance, a few up to about $100 \text{ }\mu\text{m}$) shown as trench isolation or isle partitioning borders **84**. Main cell (or icell) peripheral boundary or edge region **82** has a total peripheral length of $4L$; however, the total icell edge boundary length comprising the peripheral dimensions of all the isles comprises cell peripheral boundary **82** (also referred to as cell outer periphery) and trench isolation borders **84**. In the representative example of **Fig. 7D** showing an icell with $K = 4 \times 3 \times 3 = 36$ triangular isles, $K = 36$, so total cell edge length is $7.2426 \times$ cell outer periphery $4L = 28.970L$ (hence, this icell has a peripheral dimension which is 7.2426 times larger than that of the standard prior art cell shown in **Fig. 1**). For a square-shaped master cell or icell with dimensions $156 \text{ mm} \times 156 \text{ mm}$, each triangular isle or sub-cell in this embodiment has an area of 6.76 cm^2 per isle.

[0122] **Fig. 7E** is a diagram of a top view of uniform triangular-shaped isles in an isled master solar cell or icell **90** defined by cell peripheral boundary **92** and having a side length **L** and comprising an arrangement of thirty two uniform (equal areas) triangular-shaped isles I_1 through I_{32} . Each triangular isle or sub-cell or mini-cell or tile is defined by an internal isle peripheral boundary (for example, an isolation trench cut through the master cell semiconductor substrate thickness and having a trench width substantially

smaller than the isle side dimension, with the trench width no more than 100's of microns and often less than or equal to about 100 μm – for instance, a few up to about 100 μm) shown as trench isolation or isle partitioning borders **94**. Main cell (or icell) peripheral boundary or edge region **92** has a total peripheral length of $4L$; however, the total icell edge boundary length including the peripheral dimensions of all the isles comprises cell peripheral boundary **92** (also referred to as cell outer periphery) and trench isolation borders **94**. In the representative example of **Fig. 7E** showing an icell with $K = 2 \times 4 \times 4 = 32$ triangular isles, $K = 32$, so total cell edge length is $6.8284 \times$ cell outer periphery $4L = 27.313L$ (hence, this icell has a peripheral dimension which is 6.8284 times larger than that of the standard prior art cell shown in **Fig. 1**). For a square-shaped master cell or icell with dimensions 156 mm x 156 mm, triangular isle side dimensions are approximately 39 mm x 39 mm (for the two equal right-angle sides of the triangle) and each triangular isle or sub-cell in this embodiment has an area of 7.605 cm^2 per isle.

[0123] Thus, design of isles or mini-cells may include various geometrical shapes such as squares, triangles, rectangles, trapezoids, polygons, honeycomb hexagonal isles, or many other possible shapes and sizes. The shapes and sizes of isles, as well as the number of isles in an icell may be selected to provide optimal attributes for one or a combination of the following considerations: (i) overall crack elimination or mitigation in the master cell (icell); (ii) enhanced pliability and flexibility / bendability of master cell (icell) without crack generation and/or propagation and without loss of solar cell or module performance (power conversion efficiency); (iii) reduced metallization thickness and conductivity requirements (and hence, reduced metallization material consumption and processing cost) by reducing the master cell (icell) current and increasing the icell voltage (through series connection or a hybrid parallel-series connection of the isles in the monolithic icell, resulting in scaling up the voltage and scaling down the current); and (iv) providing relatively optimum combination of electrical voltage and current ranges in the resulting icell to facilitate and enable implementation of inexpensive distributed embedded electronics components on the icells and/or within the laminated PV modules comprising icells, including but not limited to at least one bypass switch (e.g., rectifying pn junction diode or Schottky barrier diode) per icell, maximum-power-point tracking (MPPT) power optimizers (at least a plurality of MPPT power optimizers embedded in each

module, with each MPPT power optimizer dedicated to at least 1 to a plurality of series-connected and/or parallel-connected icells), PV module power switching (with remote control on the power line in the installed PV array in order to switch the PV modules on or off as desired), module status (e.g., power delivery and temperature) during operation of the PV module in the field, etc. For example and as described earlier, in some applications and instances when considered along with other requirements, it may be desired to have smaller (for example triangular shaped) isles near the periphery of the master cell (icell) to reduce crack propagation and/or to improve flexibility / bendability of the resulting icells and flexible, lightweight PV modules.

[0124] A full-square master cell (icell) having an array of equivalently or uniformly sized $N \times N$ square-shaped isles or a plurality of equally sized triangular-shaped isles may be formed to match the photo-generated electrical current among isles or subgroups of isles connected in series. Thus, the square-shaped master cell (icell) may comprise $N \times N$ uniform (equally sized in terms of the isle areas) square-shaped or nearly square-shaped isles (with N being an integer: 2, 3, 4, ...) or K uniform triangular-shaped isles (with K being an integer, for example an even integer, equal to 4 or larger).

[0125] **Fig. 8** is a schematic circuit diagram showing a simplified equivalent circuit model of a typical solar cell with edge recombination effects (as well as finite series resistance and shunt resistance values, and finite dark current). A realistic solar cell includes parasitic series and shunt resistances as well as edge recombination effects and dark current, all having detrimental impacts on the solar cell performance. An ideal solar cell has a zero series resistance, an infinite shunt resistance, zero dark current, and negligible or zero edge recombination effects. For known conventional crystalline silicon solar cells, a typical ratio of crystalline silicon wafer solar cell edge area to cell active (sunnyside) area is on the order of at least 0.50%.

[0126] The increased edge length of the monolithic isled solar cells (icells) described herein may (but not necessarily) increase solar cell edge recombination effects; however, very effective mitigation measures may be used to substantially decrease the edge effects of the mini-cell (isle) boundary trenches. Solar cell edge recombination currents may cause non-linear shunts and linear or super-linear reverse current instead of normal saturation behavior. Thus, it may be desirable to eliminate or minimize I_{loss2} by

substantially mitigating or minimizing the edge recombination effects. Edge recombination currents may be substantially reduced and/or eliminated by taking practical and effective measures in the design and during processing of solar cells.

[0127] Edge recombination currents are caused by edge regions that are highly disturbed and/or relatively un-passivated, and edge regions which may be in direct contact with the pn-junction (i.e., the solar cell pn junction and its depletion region contacting the edge regions). Edge losses occur due to cell damage (e.g., residual edge sidewall damage if not properly removed by an effective process, such as during the texturization wet etch after formation of the icell trenches, as described earlier) and poor or insufficient passivation of the solar cell edge sidewall areas (the main cell peripheral sidewall areas as well as the partitioning trench sidewall areas in the case of icells) and may be further exacerbated when the solar cell pn junction contacts the solar cell edge area (either around the main solar cell peripheral sidewalls and/or the partitioning trench sidewall areas in icells). To mitigate this problem, isle isolation trench formation followed by wet texture (silicon etch) also removing any residual trenching damages in the crystalline semiconductor layer sidewalls, wrap-around passivation (formed during the frontside passivation process) to passivate both the sunnyside / frontside surfaces and sidewalls of the edge regions of all the isles, and/or eliminating pn junction contact with edges of isles substantially reduce or eliminate the edge recombination effects from solar cells (icells). Measures to minimize or eliminate the trench isolation edge recombination currents in monolithic isled (tiled) solar cells (icells) which may be used individually or in combination, include: 1) separate/recess the emitter junction (for instance, the p+n emitter junction when using n-type base) of each isle (or mini-cell or sub-cell or tile) from the trench isolation edge (and from the main icell boundary edges) by a narrow base (e.g., n-type base when using n-type base and p+n emitter junction) rim, the separation may be as small as a one micron and as large as 100's of microns depending on the master cell (icell) size and isle size (and resolution of pattern formation during solar cell processing); 2) use laser scribing to form trench isolation regions from the cell sunnyside before wet etch texture process (to allow for the wet texture etch chemistry to etch off and remove any trenching-induced residual damage in the sidewalls of isles or mini-cells as well as the main boundary sidewalls of the icell; 3) perform wet etch texture

which also removes a portion of crystalline silicon (for instance, from a few microns up to about 15 microns of silicon) to remove any process-induced (for instance, pulse-laser-ablation induced or mechanical dicing induced) damaged silicon from trench-partitioned edges (may be performed concurrent with the wet texture processing using either alkaline texture etch and/or acidic texture etch); and, 4) perform passivation / ARC process on the solar cell (icell) sunnyside after icell trench partitioning and wet etch texturing / surface cleaning, for instance by Plasma-Enhanced Chemical-Vapor Deposition (PECVD) and/or another suitable process such as Atomic Layer Deposition (ALD), which would also effectively cover and passivate all the sidewall edge regions, including the main icell peripheral boundary sidewalls as well as the trench sidewalls of all the isles, to substantially reduce or eliminate edge recombination loss effects. These measures will further enhance the substantial benefits of icell embodiments.

[0128] The following exemplary solar cell designs and manufacturing processes utilize a multi-layer metallization structure, and specifically two levels (or two layers) of solar cell metallization (i.e., dual layer metallization) which are physically separated by an electrically insulating backplane layer (backplane layer attached to the backside of the solar cell). For example, prior to backplane attachment (for instance, lamination of a thin prepreg sheet), the solar cell base and emitter contact metallization pattern (first layer of patterned metallization or M1) is formed directly on the solar cell backside, for instance using a relatively thin layer of screen printed paste (e.g., paste comprising aluminum or aluminum-silicon alloy) or plasma sputtered or evaporated (PVD) aluminum (or aluminum silicon alloy) material layer (followed by laser ablation or etchant patterning in the case of PVD-formed metal layer). This first patterned layer of metallization (herein also referred to as M1) defines the solar cell contact metallization pattern, such as fine-pitch interdigitated back-contact (IBC) conductor fingers defining the base and emitter metallization regions of the IBC cell. The M1 layer extracts the solar cell electrical power (current and voltage of the solar cell) and transfers the solar cell electrical power to the second patterned level/layer of higher-conductivity solar cell metallization (herein referred to as M2) formed after M1. The second layer or level of patterned metallization (M2) may comprise a relatively inexpensive and high-electrical-conductivity metal layer

such as aluminum and/or copper (along with a suitable thin capping layer of NiV or Ni or another suitable capping metal).

[0129] As described with reference to the flow outlined in **Fig. 4**, after attachment or lamination of the backplane to the partially-processed solar cell backside (full attachment or lamination to the solar cell backside on and in around patterned M1 layer and exposed areas of the backside passivation layer), subsequent detachment of the backplane-supported solar cell from the template (in case of solar cells made using epitaxial silicon lift-off processing) OR subsequent optional silicon substrate thinning etch (in case of solar cells made using starting crystalline silicon wafers), completion of the frontside texture (e.g., using a wet alkaline or acidic wet etch texturization process) and frontside passivation and ARC deposition processes, and drilling of the via holes through the backplane layer, the patterned high sheet conductivity M2 layer is formed on the backplane (which forms both the patterned M2 layer as well as the conductive via plugs for the electrical interconnections between the patterned M2 and M1 metallization layers). Via holes (for instance, in the range of hundreds to thousands of via holes on the backplane for each solar cell) are drilled into the backplane (for example by laser drilling). These drilled via holes land on pre-specified regions of patterned M1 for subsequent electrical interconnections between the patterned M2 and M1 layers through conductive via plugs formed in these via holes (plugs may be formed concurrent with and as part of the patterned M2 formation process, or separately). Subsequently, the patterned higher-conductivity metallization layer M2 may be formed (for example, by screen printing, thermal or electron-beam evaporation, plasma sputtering, plating, or a combination thereof – using a relatively inexpensive high-conductivity M2 material comprising aluminum and/or copper). For an interdigitated back-contact (IBC) solar cell (icell) with M1 fine-pitch IBC fingers (for instance, hundreds of interdigitated M1 fingers per icell), the patterned M2 layer may be designed to be substantially orthogonal or perpendicular to the patterned M1 fingers – in other words the patterned M2 rectangular or tapered (e.g., triangular or trapezoidal) fingers are essentially perpendicular to the M1 fingers. Because of this orthogonal transformation of M2 fingers with respect to M1 fingers, the patterned M2 layer may have far fewer IBC fingers than the M1 layer (for instance, by a factor of about 10 to 50 fewer M2 fingers per mini-cell or unit-cell in some

instances). Hence, the M2 layer may be formed in a much coarser pattern with much wider IBC fingers (and much larger base-emitter metal finger pitch) than the interdigitated M1 layer. Solar cell busbars may be positioned on the M2 layer, and not on the M1 layer (in other words a busbarless patterned M1 layer), to eliminate electrical shading losses associated with on-cell busbars. As both the base and emitter interconnections and busbars may be positioned on the patterned M2 layer on the solar cell backside backplane, electrical access is provided to both the base and emitter terminals of the solar cell on the backplane from the backside of the solar cell.

[0130] The continuous backplane material formed between the patterned M1 and M2 layers may be a thin sheet of an electrically insulating material, for instance, a suitable polymeric material such as an aramid fiber prepreg material, with sufficiently matching coefficient of thermal expansion (CTE) with respect to CTE of the semiconductor layer (e.g., crystalline silicon for crystalline silicon solar cells) to avoid causing excessive thermally induced stresses on the thin silicon layer. Moreover, the backplane layer should meet the solar cell process integration requirements for the backend cell fabrication processes, in particular relatively good chemical resistance during optional wet silicon thinning etch and during wet texturing of the cell frontside, and relatively good thermal stability (for instance, up to about 400°C thermal stability) during the subsequent deposition of the frontside passivation and ARC layer(s) as well as during the subsequent M2 fabrication process (if applicable). The electrically insulating continuous backplane layer should also meet the module-level lamination processing and long-term PV module reliability requirements. While various suitable polymeric (such as plastics, fluoropolymers, prepreps, etc.) and suitable non-polymeric materials (such as glass, ceramics, etc.) may be used as the electrically insulating backplane material, the desired backplane material choice depends on many considerations including, but not limited to, cost, ease of process integration, relative CTE match to silicon, thermal stability, chemical resistance, reliability, flexibility / pliability, etc.

[0131] One suitable material choice for the continuous backplane layer is prepreg sheet (comprising a combination of fibers and resin). Prepreg sheets are used as building blocks of printed circuit boards and may be made from combinations of resins and CTE-reducing fibers or particles. The backplane material may be a relatively inexpensive, low-

CTE (typically with CTE <10 ppm/ $^{\circ}\text{C}$, or in some instances with CTE <5 ppm/ $^{\circ}\text{C}$), thin (usually 50 microns to 250 microns, and in some instances in the range of about 50 to 150 microns) prepreg sheet which is relatively chemically resistant to the optional silicon thinning etch chemistry (e.g., alkaline or acidic silicon etch chemistry) and texturization chemicals (e.g., alkaline or acidic silicon texturization chemistry), and is relatively thermally stable at temperatures up to at least 180°C (and in some instances to temperatures as high as about 400°C during the back-end solar cell processing). In the case of solar cells fabricated using epitaxial silicon lift-off processing, the prepreg sheet may be attached to the solar cell backside after completion of the solar cell backside processing through the formation of the patterned M1 layer, while still on the reusable template (before the cell lift off release process if applicable) using a thermal-vacuum laminator. Alternatively in the case of solar cells fabricated using crystalline silicon wafers (no epitaxial lift-off processing), the prepreg sheet may be attached to the solar cell wafer backside after completion of the solar cell backside processing through the formation of the patterned M1 layer, again using a thermal-vacuum laminator. Upon applying a combination of heat and pressure, the thin continuous prepreg sheet (for instance, a 50 to 250 micron thick layer of aramid fiber prepreg sheet) is permanently laminated or attached to the backside of the processed solar cell (or a plurality of solar cells in the case of monolithic module embodiment). Then, as applicable in the case of solar cells fabricated using epitaxial silicon lift-off processing, the lift-off release boundary is defined around the periphery of the solar cell (near the reusable template edges), for example by using a pulsed laser scribing tool, and the backplane-laminated solar cell is then lifted off and separated from the reusable template using a mechanical release or lift-off process (the solar cells made on starting crystalline silicon wafers do not use a lift-off release process and directly proceed to the back-end solar cell processing after the backplane attachment / lamination process). Subsequent back-end process steps may include: (i) optional silicon thinning etch in the case of solar cells made on starting crystalline silicon wafers, completion of the wet texture and passivation and ARC deposition processes on the solar cell sunnyside, (ii) completion of formation of the solar cell backplane via holes and high-conductivity second layer metallization (M2) on the backplane-attached solar cell backside (which is formed on the solar cell backplane

surface). The high-conductivity metallization for patterned M2 (for example comprising aluminum and/or copper, as opposed to silver in order to reduce the overall solar cell manufacturing and material costs) including interdigitated M2 metal fingers for both the emitter and base polarities is formed on the laminated solar cell backplane comprising the laser-drilled via holes.

[0132] As noted before, the backplane material may be made of a thin (for instance, about 50 to 250 microns in thickness), flexible, and electrically insulating polymeric material sheet such as a relatively inexpensive prepreg material commonly used in printed circuit boards (PCB) and other industrial applications, which meets the overall process integration and reliability requirements. Generally, prepregs are reinforcing materials pre-impregnated with resin and ready to use to produce composite parts (prepregs may be used to produce composites faster and easier than wet lay-up systems). Prepregs may be manufactured by combining reinforcement fibers or fabrics with specially formulated pre-catalyzed resins using equipment designed to ensure consistency. Covered by a flexible backing paper, prepregs may be easily handled and remain flexible / pliable for a certain time period (out-life) at room temperature. Further, prepreg advances have produced materials which do not require refrigeration for storage, prepregs with longer shelf life, and products that cure at lower temperatures. Prepreg laminates may be cured by heating under pressure (heat-pressure lamination). Conventional prepregs are formulated for autoclave curing while low-temperature prepregs may be fully cured by using vacuum bag pressure alone at much lower temperatures.

[0133] As disclosed and discussed previously, the monolithically isled cell (icell) designs and fabrication methods disclosed herein may be integrated with known solar cell designs and fabrication process flows, including for back-contact solar cells, without substantially altering or adding manufacturing process steps or tools, and thus without substantially adding to the cost of manufacturing the solar cell. In fact, the manufacturing costs of solar cells and modules may be reduced as a result of the icell innovations (as well as the monolithic module embodiment innovations comprising icells). In one embodiment, the combination of cell designs in conjunction with a continuous backplane and metallization structure (specifically two patterned metallization layers or levels – M1 and M2) provides

a back-junction/back-contact solar cell architecture. However, various combinations of the backplane and metallization layers may serve as permanent flexible or semi-flexible or rigid structural support/reinforcement and provide high-conductivity (e.g., comprising aluminum and/or copper metallization material) interconnects for a high-efficiency crystalline silicon solar cell without significantly compromising solar cell power or adding to solar cell manufacturing cost.

[0134] Fig. 9A is a schematic diagram showing a backside plan view of a busbarless first metallization layer pattern (M1) formed on master cell or icell with 4 x 4 square-shaped isles (this icell M1 pattern rear view corresponds to the frontside view shown in **Fig. 2** for an icell with the same 4 x 4 square-shaped isles arrangement). **Fig. 9B** is an expanded view of a section of the schematic diagram of **Fig. 9A**, showing the expanded backside plan view of one of the isles of **Fig. 9A** (e.g., the isle designated by I14), indicating its island of busbarless first metallization layer pattern (M1) interdigitated base and emitter metal fingers, electrically isolated from the interdigitated base and emitter M1 fingers of the other isles in the icell.

[0135] Fig. 9A is a schematic diagram showing a backside plan view of a busbarless first metallization layer pattern (M1), comprising a plurality of islands (corresponding to the plurality - 4x4 array in this representative example - of isles in the icell) of patterned fine-pitch interdigitated base and emitter metallization fingers, formed on master cell or icell **100** prior to the backplane attachment or lamination to the epitaxially grown (e.g., on porous silicon on template) or crystalline wafer-based semiconductor substrate. This design corresponds to the icell with a 4 x 4 array of square-shaped isles shown in **Fig. 2**. **Fig. 9B** is an expanded backside view of a solar cell isle from **Fig. 9A** with its patterned M1 metallization layer forming the fine-pitch busbarless interdigitated base and emitter metallization fingers (for instance, for the back-junction/ back-contact or IBC icell or master cell). Consistent with the icell embodiment as described previously with reference to **Fig. 2**, partially-processed master cell or icell **100** (processed through the first layer or level of patterned metal M1) is defined by cell peripheral boundary **106** and, in this representative embodiment, comprises $4 \times 4 = 16$ uniform (equal isle areas) square-shaped isles I₁₁ through I₄₄ to be subsequently defined (after the backplane attachment or lamination to the solar cell backside) by formation of the partitioning

trench isolation borders, shown as borders **104** projected towards this backside view from frontside of the solar cell where the partitioning trenches will be formed. Note that the partitioning trenches will be formed from the sunnyside of the semiconductor substrate on the opposite side of the backplane. In **Figs. 9A** and **Fig. 9B**, the isle-partitioning borders **104** also define the M1 metallization islands (plurality of islands of interdigitated base and emitter metallization fingers formed by patterned M1) for the isles forming the icell (array of 4x4 isles in this embodiment). The 4 x 4 islands of interdigitated M1 fingers may be physically separated (i.e., the interdigitated fingers do not cross or violate the partitioning borders **104**) and electrically isolated from each other. The entire plurality of patterned M1 islands (4 x 4 array of M1 islands in this embodiment, comprising a relatively high conductivity and inexpensive metal capable of making good ohmic contacts to both n-type and p-type silicon, such as aluminum) are formed concurrently on the backside of the solar cell by a suitable process such as screen printing of a suitable paste (aluminum or aluminum-silicon alloy paste) or PVD and post-PVD patterning (by pulsed laser ablation patterning or patterned etching). The isles or sub-cells or mini-cells, are monolithically formed (from the same initially continuous semiconductor layer) trench partitioned and isolated islands of a semiconductor layer (for example, an epitaxially grown silicon layer or a silicon layer from a starting crystalline silicon wafer)) on a shared continuous or continuous backplane layer / sheet (backplane not shown here but will be attached or laminated to the solar cell backside comprising the backside passivation and patterned on-cell M1 layers). The plurality of islands (4 x 4 = 16 in this embodiment) of patterned M1 interdigitated metallization fingers **102** are formed on the solar cell backside corresponding to and consistent with the icell pattern of trench-partitioned semiconductor isles on the solar cell frontside, with each island of interdigitated base and emitter metal fingers corresponding to the M1 metallization for each isle. The interdigitated base and emitter metal fingers on each M1 islands are shown without cell busbars on the M1 pattern (shown as alternating emitter M1 metal fingers **110** and base M1 metal fingers **112** formed on solar cell substrate backside **108**, prior to the backplane attachment) – thus, there are no on-cell busbars. As shown in **Fig. 9A** and **Fig. 9B**, the patterned interdigitated M1 metallization fingers for each M1 island (corresponding to each trench-partitioned isle for the resulting icell) are physically and

electrically isolated from the patterned interdigitated M1 metallization fingers of the other neighboring islands. Mostly but not necessarily, the electrical interconnections among various trench-partitioned isles of an icell are made through the second patterned metallization layer M2 after completion of the backplane attachment to the partially-processed solar cell backside and towards the end of the back-end processing of the solar cell. Some embodiments may utilize the patterned M1 layer to also interconnect the adjacent or neighboring trench-partitioned isles, for instance, in electrical parallel and/or series connections. In some instances, if applicable and desired, M1 metallization layer may be formed on the solar cell substrate backside **108**, such as in the case of solar cell being made from an epitaxially grown silicon substrate, while the partially-processed epitaxial solar cell is still attached to its supporting crystalline silicon template structure on the cell sunnyside. This was described earlier in conjunction with the epitaxial silicon solar cell fabrication process flows.

[0136] Fig. 10A is a schematic diagram showing a backside plan view of a busbarless first metallization layer pattern (M1) formed on master cell or icell with 3 x 3 square-shaped isles (this icell M1 pattern rear view corresponds to the frontside view shown in **Fig. 6A** for an icell with the same 3 x 3 square-shaped isles arrangement). **Fig. 10B** is a schematic diagram showing a backside plan view of a busbarless first metallization layer pattern (M1) formed on master cell or icell with 5 x 5 square-shaped isles (this icell M1 pattern rear view corresponds to the frontside view shown in **Fig. 6B** for an icell with the same 5 x 5 square-shaped isles arrangement).

[0137] Figs. 10A and 10B are a schematic diagrams showing a backside plan views of a busbarless first metallization layer pattern (M1), comprising a plurality of M1 metal pattern islands (corresponding to the $3 \times 3 = 9$ array in **Fig. 10A** and $5 \times 5 = 25$ array in **Fig. 10B** in these representative examples - of isles in the icell) of patterned fine-pitch interdigitated base and emitter metallization fingers, formed on master cell or icell **120** in **Fig. 10A** and **130** in **Fig. 10B** prior to the backplane attachment or lamination to the epitaxially grown (on template) or crystalline wafer-based semiconductor substrate. These designs correspond to the icells with a 3 x 3 array of isles shown in **Fig. 6A** and the icells with a 5 x 5 array of isles shown in **Fig. 6B**). In **Fig. 10A**, consistent with the icell embodiment as described previously with reference to **Fig. 6A**, partially-processed

master cell or icell **120** (processed through the first layer or level of patterned metal M1) is defined by cell peripheral boundary **126** and, in this representative embodiment, comprises $3 \times 3 = 9$ uniform (equal isle areas) square-shaped isles I_{11} through I_{33} to be subsequently defined (after the backplane attachment or lamination to the solar cell backside) by formation of the partitioning trench isolation borders, shown as borders **124** projected towards this backside view from the frontside of the solar cell where the partitioning trenches will be formed through the semiconductor layer. Note that the partitioning trenches will be formed from the sunnyside of the semiconductor substrate on the opposite side of the backplane. In **Fig. 10A**, the partitioning borders **124** also define the M1 metallization islands (plurality of islands of interdigitated base and emitter metallization fingers) for the isles forming the icell (3×3 isles in this embodiment). The 3×3 islands of interdigitated M1 fingers may be physically separated (i.e., the interdigitated fingers do not cross or violate the partitioning borders **124**) and electrically isolated from each other. The entire plurality of patterned M1 islands (3×3 array of M1 islands in this embodiment, comprising a relatively high conductivity and inexpensive metal capable of making good ohmic contacts to both n-type and p-type silicon, such as aluminum) are formed concurrently on the backside of the solar cell by a suitable process such as screen printing of a suitable paste (such as a paste comprising aluminum or aluminum-silicon alloy) or PVD and post-PVD patterning (by pulsed laser ablation patterning or patterned etching). The isles or sub-cells or mini-cells, are monolithically formed (from the same initially continuous semiconductor layer) trench partitioned and isolated islands of a semiconductor layer (for example, an epitaxially grown silicon layer or a silicon layer from a starting crystalline silicon wafer) on a shared continuous or continuous backplane layer / sheet (backplane not shown here but will be attached or laminated to the solar cell backside comprising the backside passivation and patterned on-cell M1 layers). The plurality of islands ($3 \times 3 = 9$ in this embodiment) of patterned M1 interdigitated metallization fingers **122** are formed on the solar cell backside corresponding to and consistent with the icell pattern of trench-partitioned semiconductor isles on the solar cell frontside, with each island of interdigitated base and emitter metal fingers corresponding to the metallization region for each isle. The interdigitated base and emitter metal fingers on each M1 islands are shown without cell

busbars on the M1 pattern (shown as alternating emitter and base M1 metal lines **122** formed on solar cell substrate backside, prior to the backplane attachment) – thus, there is no on-cell busbar. As shown in **Fig. 10A**, the patterned interdigitated M1 metallization fingers for each M1 island (corresponding to each trench-partitioned isle for the resulting icell) are physically and electrically isolated from the patterned interdigitated M1 metallization fingers of the other neighboring islands. In some instances the electrical interconnections among various trench-partitioned isles of an icell are made through the second patterned metallization layer M2 after completion of the backplane attachment to the solar cell backside and towards the end of the back-end processing of the solar cell. Some embodiments may utilize the patterned M1 layer to also interconnect some adjacent or neighboring trench-partitioned isles, for instance, in electrical parallel and/or connections. In some instances, if applicable and desired, M1 metallization layer may be formed on the solar cell substrate backside, such as in the case of solar cell being made from an epitaxially grown silicon substrate, while the partially-processed epitaxial solar cell is still attached to its supporting crystalline silicon template structure on the cell sunnyside. This was described earlier in conjunction with the epitaxial silicon solar cell fabrication process flows.

[0138] In **Fig. 10B**, consistent with the icell embodiment as described previously with reference to **Fig. 6B**, partially-processed master cell or icell **130** (processed through the first layer or level of patterned metal M1) is defined by cell peripheral boundary **136** and, in this representative embodiment, comprises $5 \times 5 = 25$ uniform (equal isle areas) square-shaped isles I_{11} through I_{55} to be subsequently defined (after the backplane attachment or lamination to the solar cell backside) by formation of the partitioning trench isolation borders, shown as borders **134** projected towards this backside view from the frontside of the solar cell where the partitioning trenches will be formed. Note that the partitioning trenches will be formed from the sunnyside of the semiconductor substrate on the opposite side of the backplane. In **Fig. 10B**, the partitioning borders **134** also define the M1 metallization islands (plurality of islands of interdigitated base and emitter metallization fingers) for the isles forming the icell ($5 \times 5 = 25$ isles in this embodiment). The $5 \times 5 = 25$ islands of interdigitated M1 fingers may be physically separated (i.e., the interdigitated fingers do not cross or violate the partitioning borders **134**) and electrically

isolated from each other. The entire plurality of patterned M1 islands ($5 \times 5 = 25$ array of M1 islands in this embodiment, comprising a relatively high conductivity and inexpensive metal capable of making good ohmic contacts to both n-type and p-type silicon, such as aluminum) are formed concurrently on the backside of the solar cell by a suitable process such as screen printing of a suitable paste (such as comprising aluminum or aluminum-silicon alloy) or PVD and post-PVD patterning (by pulsed laser ablation patterning or patterned etching). The isles or sub-cells or mini-cells, are monolithically formed (from the same initially continuous semiconductor layer) trench partitioned and isolated islands of a semiconductor layer (for example, an epitaxially grown silicon layer or a silicon layer from a starting crystalline silicon wafer) on a shared continuous or continuous backplane layer / sheet (backplane not shown here but will be attached or laminated to the solar cell backside comprising the backside passivation and patterned on-cell M1 layers). The plurality of islands ($5 \times 5 = 25$ in this embodiment) of patterned M1 interdigitated metallization fingers **132** are formed on the solar cell backside corresponding to and consistent with the icell pattern of trench-partitioned semiconductor isles on the solar cell frontside, with each island of interdigitated base and emitter metal fingers corresponding to the M1 metallization region for each isle. The interdigitated base and emitter metal fingers on each M1 islands are shown without cell busbars on the M1 pattern (shown as alternating emitter and base M1 metal lines **132** formed on solar cell substrate backside, prior to the backplane attachment) – thus, there are no on-cell busbars (to prevent or minimize electrical shading losses). As shown in **Fig. 10B**, the patterned interdigitated M1 metallization fingers for each M1 island (corresponding to each trench-partitioned isle for the resulting icell) are physically and electrically isolated from the patterned interdigitated M1 metallization fingers of the other neighboring islands. The electrical interconnections among various trench-partitioned isles of an icell may be made through the second patterned metallization layer M2 after completion of the backplane attachment to the solar cell backside and towards the end of the back-end processing of the solar cell. Some embodiments may utilize the patterned M1 layer to also interconnect the adjacent or neighboring trench-partitioned isles, for instance, in electrical parallel connection. In some instances, if applicable and desired, M1 metallization layer may be formed on the solar cell substrate backside, such as in the case of solar cell being made

from an epitaxially grown silicon substrate, while the partially-processed epitaxial solar cell is still attached to its supporting crystalline silicon template structure on the cell sunnyside. This was described earlier in conjunction with the epitaxial silicon solar cell fabrication process flows.

[0139] Fig. 11A is a schematic diagram showing a backside plan view of a busbarless first metallization layer pattern (M1) formed on master cell or icell with $4 \times 3 \times 3 = 36$ triangular-shaped isles (this icell M1 pattern rear view corresponds to the frontside view shown in **Fig. 7D** for an icell with the same $4 \times 3 \times 3 = 36$ triangular-shaped isles arrangement). **Fig. 11B** is an expanded view of a section of the schematic diagram of **Fig. 11A**, showing the expanded backside plan view of a group of triangular isles of **Fig. 11A** (e.g., the isles designated by I1, I2, I3, I4), indicating their triangular-shaped island of busbarless first metallization layer pattern (M1) interdigitated base and emitter metal fingers, electrically isolated from each other and the interdigitated base and emitter M1 fingers of the other isles in the icell.

[0140] Fig. 11A is a schematic diagram showing a backside plan views of a busbarless first metallization layer pattern (M1), comprising a plurality of islands (corresponding to the plurality – $4 \times 3 \times 3 = 36$ array of triangular isles in the icell in this representative example) of patterned fine-pitch interdigitated base and emitter metallization fingers, formed on master cell or icell **140** prior to the backplane attachment or lamination to the epitaxially grown (on template) or crystalline wafer-based semiconductor substrate. This design corresponds to the icell with $4 \times 3 \times 3$ array of isles shown in **Fig. 7D**. **Fig. 11B** is an expanded backside view of a solar cell isle from **Fig. 11A** with its patterned M1 metallization layer forming the fine-pitch busbarless interdigitated base and emitter metallization fingers (for the back-junction/ back-contact or IBC solar cell). Consistent with the icell embodiment as described previously with reference to **Fig. 7D**, partially-processed master cell or icell **140** (processed through the first layer or level of patterned metal M1) is defined by master cell or icell peripheral boundary **146** and, in this representative embodiment, comprises $4 \times 3 \times 3 = 36$ uniform (equal isle areas) triangular-shaped isles I₁ through I₃₆ to be subsequently defined (after the backplane attachment or lamination to the solar cell backside) by formation of the partitioning trench isolation borders through the semiconductor layer, shown as various border lines

144 and 154 (shown as dark axial – horizontal and vertical – lines, and white diagonal border lines, separating the triangular islands of interdigitated M1 metal fingers) projected towards this backside view from the frontside of the solar cell semiconductor substrate where the partitioning trenches will be formed. Note that the partitioning trenches will be formed from the sunnyside of the semiconductor substrate on the opposite side of the backplane. In **Fig. 11A** and **Fig. 11B**, the horizontal and vertical (also called axial herein) partitioning borders **144** and triangular pattern partitioning diagonal or angled borders **154** (shown as horizontal and vertical or axial dark lines as well as diagonal white lines – dark lines and white lines simply distinguish between the axial X and Y direction isle-partitioning borders vs. diagonal direction isle-partitioning borders) also define the M1 metallization islands (plurality of triangular-shaped islands of interdigitated base and emitter metallization fingers) for the triangular isles forming the icell ($4 \times 3 \times 3 = 36$ isles in this embodiment). The $4 \times 3 \times 3 = 36$ islands of interdigitated M1 fingers may be physically separated (i.e., the interdigitated fingers do not cross the partitioning borders **144 and 154**) and electrically isolated from each other. The entire plurality of patterned M1 islands ($4 \times 3 \times 3 = 36$ array of M1 islands in this embodiment, comprising a relatively high conductivity and inexpensive metal capable of making good ohmic contacts to both n-type and p-type silicon, such as aluminum) are formed concurrently on the backside of the solar cell by a suitable process such as screen printing of a suitable paste (such as a paste comprising aluminum or aluminum-silicon alloy) or PVD and post-PVD patterning (by pulsed laser ablation patterning or patterned etching). The isles or sub-cells or mini-cells, are monolithically formed (from the same initially continuous semiconductor layer) trench partitioned and isolated islands of a semiconductor layer (for example, an epitaxially grown silicon layer on porous silicon on template or a silicon layer from a starting crystalline silicon wafer)) on a shared continuous or continuous backplane layer / sheet (backplane not shown here but will be attached or laminated to the solar cell backside comprising the backside passivation and patterned on-cell M1 layers). The plurality of islands ($4 \times 3 \times 3 = 36$ in this embodiment) of patterned M1 interdigitated metallization fingers **142** are formed on the solar cell backside corresponding to and consistent with the icell pattern of trench-partitioned semiconductor isles on the solar cell frontside, with each island of interdigitated base and

emitter metal fingers corresponding to the M1 metallization for each isle. The interdigitated base and emitter metal fingers on each M1 islands are shown without cell busbars on the M1 pattern (shown as alternating emitter M1 fingers **150** and base M1 fingers **152** formed on solar cell substrate backside **148**, prior to the backplane attachment) – thus, there are no on-cell busbars (in order to avoid or eliminate electrical shading losses). As shown in **Fig. 11A** and **Fig. 11B**, the patterned interdigitated M1 metallization fingers for each triangular-shaped M1 island (corresponding to each trench-partitioned triangular-shaped isle for the resulting icell) are physically and electrically isolated from the patterned interdigitated M1 metallization fingers of the other neighboring islands. The electrical interconnections among various trench-partitioned isles of an icell are made through the second patterned metallization layer M2 after completion of the backplane attachment to the solar cell backside and towards the end of the back-end processing of the solar cell. Some embodiments may utilize the patterned M1 layer to also interconnect the adjacent or neighboring trench-partitioned isles, for instance, in electrical parallel and/or series connections. In some instances, if applicable and desired, M1 metallization layer may be formed on the solar cell substrate backside, such as in the case of solar cell being made from an epitaxially grown silicon substrate, while the partially-processed epitaxial solar cell is still attached to its supporting crystalline silicon template structure on the cell sunnyside. This was described earlier in conjunction with the epitaxial silicon solar cell fabrication process flows. In an icell embodiment with a plurality of triangular isles such as that shown in **Figs. 11 A and B**, a set of four triangular isles forming a square (for example isle group I_1 through I_4 forming a square and isle group I_{30} through I_{36} forming another square) may be electrically connected in parallel using second patterned metallization layer M2 (which is not shown here) and the entire set of square regions (3×3 square regions in this embodiment, with each square region comprising 4 triangular isles) may then be electrically connected in series (e.g., $3 \times 3 = 9$ square regions to be connected in electrical series), or if desired, in a hybrid parallel-series arrangement. Thus, while the number of triangular isles is $4 \times 3 \times 3 = 36$, the number of subgroups (S) connected in series (for a series-connected arrangement of groups of 4 triangular isles) is $3 \times 3 = 9$ – in other words 9 square-shaped subgroups of 4 triangles, such as I_1, I_2, I_3 , and I_4 forming a square ($P=4$

or 4 triangular isles confined within a square connected in electrical parallel by M2 and the 9 square regions each comprising 4 parallel-connected triangular isles, all connected in electrical series).

[0141] Representative M2 Metallization Embodiments

[0142] Fig. 12A is a schematic diagram showing a backside plan view of a second and final metallization layer pattern (M2) formed on master cell or icell backside for an icell with an array of 5 x 5 square-shaped isles (this M2 pattern applies to the solar cell design shown in **Fig. 6B** on which M1 is formed as shown in **Fig. 10B**). The M2 pattern shown here provides an arrangement to interconnect the array of $5 \times 5 = 25$ isles in electrical series in the icell. Patterned M2 layer is shown with substantially rectangular fingers (number of M2 fingers $\ll$ number of M1 fingers). **Fig. 12B** is an expanded view of a section of M2 structure in the schematic diagram of **Fig. 12A** showing the expanded backside plan view of the M2 pattern for a few of the series-connected isles within one quadrant region of **Fig. 11A** (e.g., including the M2 pattern for the isles designated by I14, I15, I24, I25, indicating the interdigitated base and emitter M2 metal fingers.

[0143] Fig. 12A is a schematic diagram showing a backside plan view of a second metallization layer pattern (M2) formed on master cell or icell **160** (similar to the solar cell shown in **Fig. 6B** comprising a $5 \times 5 = 25$ array of square-shaped isles, on which patterned M1 is as shown in **Fig. 10B**). **Fig. 12B** is an expanded view of the M2 metallization layer pattern in a few of the isles within a quadrant of the solar cell of **Fig. 12A**. In **Figs. 12A and B**, and as described previously with reference to **Fig. 6B** and **10B**, master cell or icell **160** is defined by solar cell peripheral boundary **164** and comprises $5 \times 5 = 25$ uniform square shaped isles I₁ through I₂₅ defined by semiconductor-layer-partitioning trench isolation borders. Patterned M2 metallization layer **162** is formed on the continuous backplane layer **177** attached or laminated to the backside of the solar cell after formation of the patterned M1 layer. The patterned M1 and M2 layers are separated from each other by the backplane layer **177** and interconnected together through the conductive via plugs as described earlier. Patterned M2 metallization layer **162** shown in **Figs. 12A and B** comprises substantially rectangular interdigitated emitter and base metal fingers which connect to the underlying patterned M1 layer through a plurality of conductive via plugs (formed by the M2 metallization process

through the laser-drilled via holes through the backplane layer). As shown, the patterned M2 interdigitated rectangular fingers (M2 emitter fingers **176** and M2 base fingers **174**) are may be patterned such that they are substantially perpendicular or orthogonal to the underlying patterned M1 interdigitated base and emitter fingers, hence, allowing for substantially smaller number of M2 base and emitter fingers as compared to the number of M1 base and emitter fingers. The isles in each column comprising a group of 5 isles in this embodiment (the master cell or icell comprising a 5 x 5 array of mini-cells or isles) are connected in electrical series by M2 series connections **170** (base M2 metal of each isle connected to the emitter M2 metal of its adjacent isle and emitter M2 metal of each isle connected to the base M2 metal of its adjacent isle in the same column and when transitioning from the end of one column to the beginning of its adjacent column; the base M2 busbar of one corner isle and the emitter M2 busbar of another diagonally opposite isle corner isle serve as the icell base and emitter busbars for icell to icell interconnections either through extensions of M2 in monolithic module embodiments or through tabbing / stringing / and/or soldering of the solar cells together when not using Monolithic Module embodiment). In order to complete the patterned M2 electrical series interconnections of array of 5 x 5 isles arranged in 5 columns, the isle columns are electrically interconnected using the patterned M2 layer, specifically by lateral M2 layer jumpers or lateral connectors **172** positioned, alternatively, at the top and bottom of the isle columns – thus, the $5 \times 5 = 25$ isles in this icell are all interconnected in electrical series using the patterned M2 layer, with the series connections starting with the top left corner isle in icell **160** of **Fig. 12A** and continuing down the first column of isles, then connecting the first leftmost column in series to the second column using a bottom M2 jumper or lateral connector **172**, with the series connections continuing up the second column of isles, then connecting the second column in series to the third column using a top M2 jumper or lateral connector **172**, with the series connections continuing down the third column of isles, then connecting the third column in series to the fourth column using a bottom M2 jumper or lateral connector **172**, with the series connections continuing up the fourth column of isles, then connecting the fourth column in series to the fifth column using a top M2 jumper or lateral connector **172**, and finally with the series connections continuing down the fifth column of isles. In this icell with an array of

5x5 series-connected isles (all isles interconnection and final icell metallization by the patterned M2 layer), emitter lead or busbar **166** (emitter terminal) for isle I₁₁ (top left corner isle) and base lead or busbar **168** (base terminal) for isle I₅₅ (bottom right corner isle) serve as the main busbars of the icell **160**. As shown, the adjacent columns of patterned M2 layer corresponding to the adjacent columns of isles (5 isles per column in this embodiment) are separated by M2 column electrical isolation gap regions **178** (i.e., no M2 metal in these isolation regions), exposing backplane layer **177**. The M2 column electrical isolation gap regions **178** are formed concurrently along with formation of all the M2-level patterned base and emitter fingers as well as emitter lead or busbar **166** (emitter terminal) and base lead or busbar **168** (base terminal) as part of monolithically-fabricated patterned M2 metallization layer. M2 series connections **170** between adjacent isles in columns electrically connect the M2 base fingers **174** from isle I₁₁ to the M2 emitter fingers **176** of isle I₂₁. The M2 base fingers **174** of isle I₂₁ are electrically connected to the M2 emitter fingers **176** of isle I₃₁ and so on vertically to isle I₅₁, hence, completing the electrical series connections of the isles in the first column. M2 series connection lateral jumper **172** electrically connects the M2 base fingers **174** of isle I₅₁ (in column 1) to M2 emitter fingers **176** of isle I₅₂ (in column 2).

[0144] Each mini-cell or isle may be connected in series to at least one of the other isles in the array, with all the isles in the array of 5 x 5 isles connected in electrical series, such as that shown in **Fig. 12A**, which is herein referred to as an all-series connection. However, parallel and hybrid parallel-series mini-cell connection patterns may also be used, depending on the applications and requirements.

[0145] As shown in **Fig. 12A**, each isle (or each sub-group of M1 parallel connected isles) has a corresponding M2 unit cell design of interdigitated rectangular fingers formed on and orthogonal to the underlying interdigitated M1 finger unit cell for that isle – I₁₁ in **Fig. 6B** corresponding to I₁₁ in **Fig. 10B** corresponding to I₁₁ in **Fig. 12A**. In some instances, it may be desired to pattern the M2 fingers parallel to the underlying interdigitated M2 fingers.

[0146] Additionally and alternatively, the metal fingers comprising the M2 unit cell design for icells may be tapered, for instance, triangular or trapezoidal shaped, as shown in **Fig. 13**. **Fig. 13** is a schematic diagram showing a backside plan view of a second

metallization layer pattern (M2) unit cell having a plurality of interdigitated tapered/ right-angle triangular base and emitter fingers. This example of an M2 unit cell design, located over each series-connected square-shaped isle or sub-group of M1-parallel-connected isles, shows $F=6$ pairs of base and emitter M2 metal fingers per isle or sub-group of M1-parallel-connected isles.

[0147] **Fig. 13** is a schematic diagram showing a backside plan view of a second metallization layer pattern (M2) unit cell **180** having, for instance, six pairs of tapered/ right-angle triangular fingers - M2 tapered base fingers **184** (all attached to M2 base busbar) and M2 tapered emitter fingers **182** (all attached to M2 emitter busbar) separated by electrical isolation gaps **186** formed during M2 patterning. The word *tapered* is used herein to describe M2 fingers which are wider at the isle busbar connection and narrower as the fingers extend from the busbar towards the other end of isle. In some instances, a tapered M2 finger design may reduce ohmic losses and reduce M2 layer thickness requirements by about 30% as compared to rectangular M2 fingers – thus allowing for a thinner M2 layer for given allowable metallization ohmic losses. Tapered base and emitter M2 fingers (tapered away from corresponding isle M2 busbar) may be shaped as nearly triangular (right-angle, equilateral, or other desired triangular shape) or nearly trapezoidal. Example dimensional considerations for designing a square shaped M2 unit cell with tapered fingers for a master cell or icell with side dimension of L (corresponding to square-shaped icell area of about $L \times L$) and $N \times N = S$ isles (S isles connected in electrical series by the patterned M2 metallization layer), and F pairs of M2 fingers per isle (or per sub-group of M1-parallel-connected isles): $L = H \times N$; $H = F \times h$; Isle Area = H^2 ; F = Number of M2 Base and Emitter Finger Pairs ($F=6$ in **Fig. 13**) – wherein: H is the side dimension of the M2 pattern per series-connected isle (or isle subgroup), h is the base width of the triangular M2 fingers, and F is the number of pairs of base and emitter M2 fingers per isle (or isle subgroup). The area of each series-connected isle (or subgroup of isles) is H^2 .

[0148] **Fig. 13** is a diagram showing a backside view of a second metallization unit cell layer pattern (M2) formed on master cell isle **180** (concurrently and monolithically along with the patterned M2 for all the other isles in the icell), having triangular-tapered interdigitated base fingers **184** and emitter fingers **182** defined and electrically isolated by

isolation metallization electrical isolation gap **186** (formed as part of patterned M2 formation). The M2 metallization pattern shown in **Fig. 13** may be positioned for example orthogonal or perpendicular to the patterned M1 fingers, on each individual isle (such as each isle connected in series with the other isles in the icell) or on a sub-group of M1-parallel-connected isles. Tapered fingers may further reduce M2 thickness requirements (typically by about 30% with respect to rectangular fingers) and allow for a thinner M2 metallization layer (due to the reduced electrical sheet conductance requirements).

[0149] Fig. 14A is a schematic diagram showing a backside plan view of a second metallization layer pattern (M2) formed on the backside of an icell (similar to the cell shown in **Fig. 2** on which patterned M1 is formed as shown in **Fig. 9A**). This shows an icell M2 pattern to make electrical series connections of the $4 \times 4 = 16$ array of square-shaped isles. Patterned M2 fingers use triangular base and emitter metal fingers (number of M2 fingers is less than the number of M1 fingers per isle). In some instances M2 fingers may be orthogonal or perpendicular to the M1 fingers. M2 fingers can be much wider and coarser pitch than M1 fingers.

[0150] Fig. 14B is a schematic diagram showing an expanded backside plan view of a portion of the solar cell from **Fig. 14A**, with a patterned M2 metallization layer, specifically showing full view of isle I14 along with partial views of isles I13, I23, and I24.

[0151] Fig. 14A is a diagram showing a backside plan view of an second metallization layer pattern (M2) formed on master cell or icell **190** (similar to the cell shown in **Fig. 2** on which patterned M1 is formed as shown in **Fig. 9A**). **Fig. 14B** is an expanded schematic plan view of a portion of the solar cell from **Fig. 14A**, with a patterned M2 metallization layer, specifically showing full view of isle I14 along with partial views of isles I13, I23, and I24. In **Figs. 14A and B**, and as described previously with reference to **Figs. 2 and 9A**, master cell or icell **190** is defined by a cell peripheral boundary **208** and comprises $4 \times 4 = 16$ uniform (equal area) square shaped isles I11 through I44 defined by partitioning trench isolation borders. Patterned M2 unit cell metallization layer **192** is formed on the backplane layer attached to the solar cell backside comprising the patterned M1 layer, and on the backside of each isle in the icell, as tapered (e.g.,

triangular shaped as shown) interdigitated emitter and base metal fingers which are electrically interconnected to the underlying M1 layer through a plurality of conductive via plugs. As shown, the patterned M2 interdigitated triangular fingers (M2 emitter fingers **206** and M2 base fingers **204** which are electrically isolated in the patterned M2 layer by isolation gaps **210**) are patterned substantially orthogonal or perpendicular to the underlying M1 interdigitated fingers allowing for substantially fewer M2 fingers as compared to the number of M1 fingers for each isle. Each isle in a column (the master cell comprising a $4 \times 4 = 16$ array of mini-cells as shown in **Fig. 14A**) connected in series by M2 series connections **200** and isle columns are interconnected by M2 lateral jumpers **202** positioned, alternatively, at the top and bottom of the isle columns – thus is the array of $4 \times 4 = 16$ isles are connected in electrical series from emitter lead **194** (emitter terminal or busbar for icell) to base lead **196** (base terminal or busbar for icell). As shown, each isle column is separated by M2 column isolation regions **198**, also formed as part of the patterned M2 formation process. M2 series connections **200** electrically connect the M2 base fingers **204** from isle I_{11} to the M2 emitter fingers **206** of isle I_{21} . The M2 base fingers **204** of isle I_{21} are electrically connected to the M2 emitter fingers **206** of isle I_{31} and so on vertically to isle I_{41} . M2 series connection lateral jumper **202** electrically connects the M2 base fingers **204** of isle I_{41} (in column 1) to M2 emitter fingers **206** of isle I_{42} (in column 2).

[0152] Fig. 15A is a schematic diagram showing a backside plan view of a second metallization layer pattern (M2) formed on master cell with $3 \times 3 = 9$ series-connected isles or sub-groups of M1-parallel-connected isles (similar to the cell shown in **Fig. 6A** on which patterned M1 is formed as shown in **Fig. 10A**). Patterned M2 fingers use triangular base and emitter metal fingers (number of M2 fingers is less than the number of M1 fingers per isle). In some instances, M2 fingers may be orthogonal or perpendicular to the M1 fingers. M2 fingers can be much wider and coarser pitch than M1 fingers.

[0153] Fig. 15A is a diagram showing a backside plan view of a second metallization layer pattern (M2) formed on master cell or icell **220** (similar to the cell shown in **Fig. 6A** on which patterned M1 is formed as shown in **Fig. 10A**). The M2 pattern shown may be formed for $3 \times 3 = 9$ series-connected isles (or sub-groups of M1-parallel-connected isles)

on a master cell providing increased voltage and decreased current as compared to a prior art single isle master cell (such as that shown in **Fig. 1**). In other words, the M2 metallization pattern may scale up the solar cell voltage (V_{mp} and V_{oc}) by a factor of nine and scale down the solar cell current (I_{mp} and I_{sc}) by a factor of nine as compared to a prior art single isle master cell. In **Fig. 15A**, and as described previously with reference to **Figs. 6A** and **10A**, icell or master cell **220** is defined by a cell peripheral boundary **238** and comprises $3 \times 3 = 9$ uniform (equal area) square shaped isles I_{11} through I_{33} defined by partitioning trench isolation borders. Patterned M2 unit cell metallization layer **222** is formed on the continuous electrically insulating backplane attached to the solar cell backside after formation of the patterned M1 layer, on the backside of each isle as tapered (e.g., triangular shaped) interdigitated emitter and base M2 metal fingers which are electrically connected to the underlying patterned M1 layer fingers through a plurality of conductive via plugs formed through the backplane. As shown, the patterned M2 interdigitated triangular fingers (M2 emitter fingers **232** and M2 base fingers **234** which are electrically isolated by isolation gaps formed during the patterned M2 formation process) are patterned substantially orthogonal or perpendicular to the underlying patterned M1 interdigitated fingers allowing for substantially fewer M2 fingers as compared to the number of M1 fingers for each isle. Each isle in a column (the master cell comprising a $3 \times 3 = 9$ array of mini-cells or isles in this embodiment) connected in series by M2 series connections **230** and isle columns are connected by lateral jumpers **228** positioned, alternatively, at the top and bottom of the isle columns – thus each isle is connected in series from emitter lead or busbar **224** (emitter terminal) to base lead or busbar **226** (base terminal). As shown, each isle column is separated by M2 column isolation regions **228** formed during the patterned M2 formation process. M2 series connections **230** electrically connect the M2 base fingers **234** from isle I_{11} to the M2 emitter fingers **232** of isle I_{21} . The M2 base fingers **234** of isle I_{21} are electrically connected to the M2 emitter fingers **232** of isle I_{31} . M2 series connection lateral jumper **228** electrically connects the M2 base fingers **234** of isle I_{31} (in column 1) to M2 emitter fingers **232** of isle I_{32} (in column 2).

[0154] **Fig. 15B** is a schematic diagram showing a backside plan view of a second metallization layer pattern (M2) formed on master cell with $5 \times 5 = 25$ series-connected

isles or sub-groups of M1-parallel-connected isles (similar to the cell shown in **Fig. 6B** on which patterned M1 is formed as shown in **Fig. 10B**). Patterned M2 fingers use triangular base and emitter metal fingers (number of M2 fingers is less than the number of M1 fingers per isle). In some instances M2 fingers may be orthogonal or perpendicular to the M1 fingers. M2 fingers can be much wider and coarser pitch than M1 fingers

[0155] Fig. 15B is a diagram showing a backside plan view of a second metallization layer pattern (M2) deposited on icell or master cell **240** (similar to the cell shown in **Fig. 6B** on which M1 is deposited as shown in **Fig. 10B**). The M2 pattern shown may be formed for $5 \times 5 = 25$ series connected isles on a master cell providing increased solar cell voltage and decreased solar cell current as compared to a prior art isle master cell. In other words, the M2 metallization pattern may scale up the voltage (V_{mp} and V_{oc}) by a factor of 25 and scale down the current (I_{mp} and I_{sc}) by a factor of 25 as compared to a prior art single isle master cell. In **Fig. 15B**, and as described previously with reference to **Figs. 6B** and **10B**, icell or master cell **240** is defined by a cell peripheral boundary **258** and comprises 25 uniform square shaped isles I_{11} through I_{55} defined by trench isolation borders. Patterned M2 unit cell metallization layer **242** is formed on the electrically insulating continuous backplane attached to the solar cell backside after formation of the patterned M1 layer, on the backside of each isle as tapered (triangular shaped) interdigitated emitter and base metal fingers which are electrically interconnected to the underlying M1 layer through a plurality of conductive via plugs through the backplane layer. As shown, the M2 interdigitated triangular fingers (M2 emitter fingers **252** and M2 base fingers **254** which are electrically isolated by isolation gaps) are patterned substantially orthogonal or perpendicular to the underlying patterned M1 interdigitated fingers allowing for substantially fewer M2 fingers as compared to the number of M1 fingers. Each isle in a column (the master cell comprising a $5 \times 5 = 25$ array of mini-cells in this embodiment) connected in series by M2 series connections **250** and isle columns are connected by lateral jumpers **248** positioned, alternatively, at the top and bottom of the isle columns – thus each isle is connected in series from emitter lead or busbar **244** (emitter terminal) to base lead or busbar **246** (base terminal). As shown, each isle column is separated by M2 column isolation regions **256**. M2 series connections **250** electrically connect the M2 base fingers **254** from isle I_{11} to the M2 emitter fingers **252** of

isle I_{21} . The M2 base fingers **254** of isle I_{21} are electrically connected to the M2 emitter fingers **252** of isle I_{31} and so on vertically to isle I_{51} . M2 series connection lateral jumper **248** electrically connects the M2 base fingers **254** of isle I_{51} (in column 1) to M2 emitter fingers **252** of isle I_{52} (in column 2).

[0156] The M1 and M2 unit cell patterns disclosed herein may be designed for square or pseudo-square shaped isles, triangular isles, or various other geometric shaped isles and any combination thereof. In other words, the isle design and interconnection pattern may dictate patterned M1 and M2 designs.

[0157] The required electrical conductivity for M2 (or the overall thickness of patterned M2 metal for a given M2 material such as Al or Cu) is less for a master cell having S isles (or S subgroups of isles) connected in electrical series (or hybrid-parallel-series) as compared to a master cell comprising a single isle because of the reduced cell current and increased cell voltage of an icell with a current and voltage scaling factor of S. Generally, the larger the value of S — in other words the number of series connected sub-cells or isles — the smaller the M2 thickness requirement as cell current is reduced and cell voltage increased by a factor of S (number of series connected isles or sub-groups of isles in the icell). For example, copper M2 layer thickness for an IBC solar cell may be decreased from the thickness range of about 20 to over 80 microns for a non-tiled solar cell (for instance, 156 mm x 156 mm IBC solar cells) such as that shown in **Fig. 1** to less than approximately 20 microns, and in some instances less than 10 microns to as low as about 1 micron to 5 microns, for tiled master cell with series-connected isles (hence, scaling up the voltage and scaling down the current for the icell by the factor S).

[0158] The monolithically tiled solar cell or icell structures and fabrication methods disclosed herein provide for substantially reduced metallization sheet conductance and thickness requirements which in turn can reduce metal consumption, process cost, fabrication process equipment cost, and corresponding capital expenditures. Further hazardous waste byproducts from particular cell fabrication processes, such as that produced during metal plating (for example copper plating), may be reduced or eliminated due to reduced and relaxed metallization sheet conductance and thickness requirements (hence, the capability to eliminate dependency on thick metal plating, by replacing it with a much simpler and lower cost metallization process such as

evaporation, plasma sputtering, and/or screen printing. A thinner and simpler M2 metallization pattern may reduce solar cell semiconductor layer microcracks and improve the overall solar cell and module manufacturing yields – for example due to substantially reduced tensile / mechanical stresses of the thinner patterned M2 metallization and elimination of dependency on metal plating processing (such as copper plating) and associated handling, edge sealing, and plating electrical contacting requirements. For applications requiring flexible or bendable solar cells and PV modules, the thinner M2 metallization layer enabled by the icell innovative aspects also enable improved flexibility and bendability of the solar cells and flexible, lightweight PV modules without increasing the risk of solar cell microcracks or breakage. Copper plating process used to form the relatively thick (e.g., about 30 to 80 microns) copper metallization for the prior art interdigitated back-contact (IBC) solar cells may degrade the manufacturing yield due to the intrusive nature of copper plating process (requiring one-sided plating, preventing exposure of the IBC solar cell frontside to the plating chemistry) and risk of mechanical breakage of the cells due to handling as well as clamping/sealing and declamping/unsealing of the solar cells during and after the plating process. For example, copper plating processing of solar cells with pre-existing microcracks may plate copper along the silicon microcracks causing hard shunts or soft shunts, resulting in yield or performance degradation. In one embodiment, the elimination of copper plating processing due to substantially reduced M2 sheet conductance (or M2 metal thickness) requirements eliminates the need for special M1 designs allowing for the patterned M2 layer to be recessed or offset from the edge of the solar cell to accommodate edge-sealed copper plating.– in other words the relaxed M2 sheet conductance requirements of the islet master cells or icells enable replacing thick copper plating process with a dry non-plating process to form the patterned M2 layer, hence eliminating the need for clamping or sealing of the frontside of the cells to eliminate exposure to plating processing. Therefore, the underlying patterned M1 fingers may be extended nearly end-to-end between the edges or partitioning borders of the isles. Further, eliminating the dependency on copper plating metallization allows for all-dry cell metallization processing (for instance, using screen printing or PVD) – thus substantially reducing cell fabrication complexity.

[0159] And in some metallization embodiments when using a metallization material other than copper (e.g., aluminum), projected long-term field reliability of the solar cells and PV modules may be improved since in solar cells using copper metallization, copper seeping to sensitive solar cell surface areas (even though not causing soft or hard solar cell shunts) may cause long-term reliability issues due to copper diffusion into the semiconductor substrate and degradation of minority carrier lifetime (and efficiency).

[0160] Thinner solar cell metallization enabled by the icell reduces solar cell bow and mechanical stress, for example on backplane-laminated solar cells disclosed herein, as compared to known solar cells using relatively thick (typically in the range of about 30 to 80 microns for IBC solar cells) plated metal, often plated copper. The reduction of M2 metal thickness in a dual level metallization structure (in one example from at least 30 to 80 microns to less than approximately 5 microns) results in enhanced solar cell and PV module flexibility/pliability without crack generation and without PV module performance degradation as a result of PV module flexing or bending. Additionally, reduction of M2 metal thickness and mass substantially reduces or eliminates mechanical stresses, such as patterned metallization stresses on the sensitive solar cell semiconductor absorber - thus, minimizing microcrack generation and yield degradation during subsequent solar cell and module processing, such as during test and sort, module lamination (which may use lamination pressure and heat), and field operation of the installed PV modules. For example, patterned M2 may be made of a relatively inexpensive, high-conductivity metal such as copper (bulk resistivity $1.68 \mu\Omega\cdot\text{cm}$) or aluminum (bulk resistivity $2.82 \mu\Omega\cdot\text{cm}$). For example, copper has a linear CTE of about $17 \text{ ppm}/^\circ\text{C}$ and crystalline silicon has a linear CTE of approximately $2.7 \text{ ppm}/^\circ$. Thus, there is an approximate CTE difference of $14 \text{ ppm}/^\circ\text{C}$ between copper and crystalline silicon, and a 140°C module lamination process would cause a dimensional mismatch of 0.25 mm or $250 \mu\text{m}$ for a 156 mm x 156 mm solar cell (in other words thick plated copper expands about 250 microns more from side to side as compared to silicon) resulting in very large tensile stress on silicon during the module lamination process. Monolithic mini-cells or isles having a patterned thin M2 metallization pattern in accordance with the disclosed subject matter (for example with a layer thickness less than approximately 10 microns, and in some instances less than 5 microns) substantially

reduces or eliminates this mode of crack generation and propagation and resulting yield degradation.

[0161] If desired, in order to eliminate the need for plating processing, such a copper plating process (as well as the cost, added process complexity, thermal/mechanical stresses, and potential fabrication yield losses associated with metal plating process), the number of series-connected sub-cells or isles (S) may be chosen such that the required low-resistivity or high-conductivity metal (for example inexpensive high-conductivity metals such as copper and/or aluminum, although another high-conductivity metal such as silver may also be used) thickness is sufficiently small in order to use a relatively low-cost metal deposition process, such as plasma sputtering or evaporation (Physical-Vapor Deposition or PVD processes), particularly in instances where the M2 thickness (such as the copper or aluminum thickness) is reduced to less than about 10 microns and in some instances less than approximately 5 microns. Alternatively, another inexpensive metallization process such as screen printing may be used instead of copper plating.

[0162] Further, in one embodiment, M2 may be patterned to be substantially orthogonal or perpendicular to M1 and the number of M2 fingers (such as tapered fingers) may be much less than the number of M1 fingers, for example by a factor in the range of about 5 to 50. And in some instances, M2 fingers designed in tapered finger shapes such as triangular or trapezoidal shapes, as compared to rectangular shaped fingers, will further reduce the M2 metal thickness requirement (typically by about 30%).

[0163] Partitioning the main/master cell into an array of isles or sub-cells (such as an array of $N \times N$ square or pseudo-square shaped or K triangular-shaped or a combination thereof) and interconnecting those isles in electrical series or a hybrid combination of electrical parallel and electrical series reduces the overall master cell current for each isle or mini-cell – for example by a factor of $N \times N = N^2$ if all the square-shaped isles are connected in electrical series, or by a factor of K if all the triangular-shaped isles are connected in series. And while the main/master cell or icell has a maximum-power (mp) current of I_{mp} , and a maximum-power voltage of V_{mp} , each series-connected isle (or sub-groups of isles connected in parallel and then in series) will have a maximum-power current of I_{mp}/N^2 (assuming N^2 isles connected in series) and a maximum-power voltage of V_{mp} (no change in voltage for the isle). Designing the first and second metallization

layer patterns, M1 and M2 respectively, such that the isles on a shared continuous or continuous backplane are connected in electrical series results in a main/master cell or icell with a maximum-power current of I_{mp}/N^2 and a maximum power voltage of $N^2 \times V_{mp}$ or a cell (icell) maximum power of $P_{mp} = I_{mp} \times V_{mp}$ (the same maximum power as a master cell without mini-cell partitioning).

[0164] Thus, a monolithically isled master cell or icell architecture reduces ohmic losses due to reduced solar cell current and allows for thinner solar cell metallization structure generally and a much thinner M2 layer if applicable or desired. Further, reduced current and increased voltage of the master cell or icell allows for relatively inexpensive, high-efficiency, maximum-power-point-tracking (MPPT) power optimizer electronics to be directly embedded into the PV module and/or integrated on the solar cell backplane.

[0165] Assume a main/master cell or icell with S square-shaped or pseudo-square shaped pattern of isles (where S is an integer and assume $S = N \times N$) or P triangular isles (where P is an integer, for example 2 or 4) with each adjacent set of P trench-isolated triangular isles forming a square-shaped sub-group of isles. Each adjacent set of P triangular isles forming a square-shaped sub-group may be connected in electrical parallel and the set of S sub-groups are connected in electrical series. The resulting main cell will have a maximum-power current of I_{mp}/S and a maximum power voltage of $S \times V_{mp}$. In practice, the reduced current and increased voltage of the isles may also allow for a relatively inexpensive, high-efficiency, maximum-power-point-tracking (MPPT) power optimizer electronics to be directly embedded into the PV module and/or integrated on the solar cell backplane. Moreover, the innovative aspects of an icell also enable distributed shade management based on implementation of inexpensive bypass diodes (e.g. pn junction diodes or Schottky diodes) into the module, for instance, one bypass diode embedded with each solar cell prior to the final PV module lamination. In a metallization embodiment, the M1 metallization layer may be a busbarless, fine-pitch (base-to-base pitch in the range of approximately about 200 μm to 2 mm, and more specifically in the range of about 500 μm to 1,500 μm) interdigitated Al and/or Al/Si metal finger pattern (formed by screen printing or PVD and post-PVD patterning) contained within each isle. For each isle, the M1 fingers may be slightly recessed from the partitioning trench isolation edges (for example recessed or offset from the isle trench isolation edges by

approximately 50 μm to 100's μm). In other words, the M1 fingers for each isle in the master cell are electrically isolated and physically separated from each other (the M1 pattern corresponding to a particular isle may be referred to herein as an M1 unit cell).

[0166] The electrical interconnection configuration of the isles (all series, hybrid parallel-series, or all parallel) may be defined by the M2 pattern design wherein M1 serves as an on-cell contact metallization for all of the master cell isles and M2 provides high-conductivity metallization and electrical interconnection of the isles within the icell or master cell.

[0167] An M2 design (for example an M2 pattern using rectangular or tapered interdigitated M2 base and emitter fingers) may provide all-series, hybrid parallel-series, or all-parallel electrical interconnections of the isles in the icell. In some instances, as noted above, M2 designs which provide all-series or hybrid parallel-series electrical connections of the isles may be used to scale up the main/master cell voltage and scale down the main/master cell current (for instance, by a factor of S, S being the number of series connected isles or sub-groups of isles). Increasing cell voltage while decreasing cell current relaxes/decreases metallization conductivity requirements and allows for thinner metallization and lower metal sheet conductance, thus reducing or mitigating process costs, process complexity, fab equipment and facilities costs (e.g., because of elimination of the need for copper plating for cell metallization), cracks, reliability concerns, and overall yield loss associated with relatively thick metallization processing such as relatively thick metallization formed using copper plating.

[0168] Moreover, the enhanced-voltage/reduced-current main/master solar cell or icell provides for the integration of a relatively inexpensive, high-performance, high-efficiency maximum-power-point-tracking (MPPT) power optimizer electronics embedded within each module and associated with each icell and/or each isle, – thus providing enhanced power and energy harvest capability across a master cell having shaded, partially shaded, and unshaded isles. Similarly, each icell or even each isle within each icell may have its own inexpensive bypass diode (pn junction diode or Schottky barrier diode) in order to provide distributed shade management capability for enhanced solar cell protection and power harvest under shading and partial shading conditions. An all-parallel electrical connection of isles provided by an all-parallel M2 pattern, as

compared to all-series or hybrid parallel-series connection, also provides some of the numerous advantages of a monolithically isled solar cell as described above, particularly the increased flexibility and bendability of the resulting icells and PV modules..

[0169] For example, in the case of using PVD aluminum for M2 (such as a sub-5 μm thick M2 layer providing all-series or hybrid parallel-series connections in an icell), a metal stack may be PVD Al (main metal) capped with a relatively thin layer of Ni or NiV (e.g., formed by plasma sputtering), optionally followed by Sn (e.g., formed by plasma sputtering) to provide M2 solderability. The aluminum layer may be deposited using an electron-beam or thermal evaporation process.

[0170] Assume there are S square-shaped isles connected in electrical series. Each “isle” to be connected in electrical series may comprise a subgroup of smaller isles, such as triangular isles, connected in electrical parallel. For an N x N array of square-shaped isles connected in series: $S = N \times N = N^2$.

[0171] Further, assume the M2 finger pattern is substantially orthogonal or perpendicular to M1 pattern - this allows the number of M2 fingers to be substantially smaller than the number of M1 fingers (by about a factor of 5x to about 50x). For instance, a 156 mm x 156 mm cell (without tiling or isles) with a base-to-base M1 metal pitch of 750 microns may have about 416 M1 fingers and approximately 8 to 40 M2 orthogonal fingers.

[0172] Similarly, a large factor reduction in the M1 to M2 finger ratio may apply to the M2 metal finger count for each isle sub-cell (the M2 pattern corresponding to a particular isle may be referred to herein as an M2 unit cell). For instance, for an S = 3 x 3 isle master cell design, each isle may have about 140 M1 fingers (running over a distance of about 52 mm in each isle) and an M2 finger count of 12 (for example with the M2 base and emitter metal fingers having combined width or pitch of about 6.5 mm, much larger than the M1 pitch of about 750 microns). And, in some instances the M2 layer may provide a relatively large cell coverage ratio (close to 100%) – in one instance the deposited M2 layer (for example deposited by PVD) is patterned using pulsed nanoseconds laser ablation creating a finger-to-finger isolation gap less than approximately 100 μm thick.

[0173] Guidelines for M2 thickness in a dual level metallization structure for a given metal - Aluminum or Copper. Assume, for master cell area = $L \times L = L^2$, I_{mp} is the

master cell maximum-power-point (MPP) current (base or emitter current) extracted from the entire M1 layer under the STC conditions. At the maximum-power-point operation of the solar cell, the entire current extracted from cell contact metallization level M1 and flowing through conductive M2-M1 via plugs is I_{mp} for base and I_{mp} for emitter ($2I_{mp}$ without current direction consideration).

[0174] Also, assume P_{mp} and V_{mp} are the maximum-power-point (MPP) power and voltage of the cell, respectively. Then: $P_{mp} = V_{mp} \times I_{mp}$; the total electrical cell current per unit area extracted from M1 (including both base and emitter currents, irrespective of flow direction) = $2I_{mp}/L^2$, as half of the cell area produces I_{mp} base current and half of the cell area produces I_{mp} emitter current; and MPP power of each isle (or sub-cell) connected in series = P_{mp}/S , where S is the number of series-connected isles or sub-groups of isles (for example: $S = N \times N = N^2$).

[0175] Now, in a triangular M2 finger embodiment, assume I_f is the current collected by each individual M2 triangular finger from the underlying M1 fingers for the triangular area covered by the M2 finger, then: $I_f = I_{mp}/(F.S)$ where F is the number of pairs of M2 triangular fingers per isle; in a base or emitter triangular finger on a series-connected isle, the finger current as a function of x may be expressed as $I(x) = \text{Integral from 0 to } x \text{ of } \{[2I_{mp}/L^2].[(x/H).h]\}.dx$ where $H = L/N$ (for $S = N \times N$) and $h = H/F = L/(N.F)$; thus, $I(x) = \text{Integral from 0 to } x \text{ of } \{[2I_{mp}/L^2].[(x/F)]\}.dx = \text{Integral from 0 to } x \text{ of } \{[2I_{mp}/(FL^2)].x.dx\}$; thus, $I(x) = [2I_{mp}/(FL^2)].(1/2)x^2 = [I_{mp}/(FL^2)].x^2$; and the total current per finger may be expressed as $I_f = [I_{mp}/(FL^2)].H^2 = [I_{mp}/(FL^2)].(L/N)^2 = [I_{mp}/(FN^2)] = I_{mp}/(F.S)$.

[0176] Further, assuming M2 resistivity ρ , thickness t , and M2 sheet resistance $R_s = \rho/t$, the power loss per M2 Finger per isle P_{If} (in other words power loss per M2 finger per M2 unit cell) may be expressed as: $P_{If} = \text{Integral from 0 to } H \text{ of } \{[(\rho.dx)/(t.x.h)/H]\}.[I_{mp}/(FL^2)]^2.x^4\}$; thus, $P_{If} = [(\rho.H)/(t.h)].[I_{mp}/(FL^2)]^2.(1/4).H^4 = [(\rho.H)/(t.h)].[I_{mp}/(FL^2)]^2.(1/4).(L/N)^4$; and as $h = H/F$ and $H/h = F$, then $P_{If} = (\rho.F/t).$

$[I_{mp}/(FL^2)]^2.(1/4).(L/N)^4$; thus, power loss per finger $P_{If} = (\rho/t).F.I_{mp}^2.(1/F^2L^4).(1/4).L^4.(1/N^4) = (\rho/t).I_{mp}^2.[1/(4.F.N^4)]$; as there are $2F$ fingers per isle, the total M2 power loss per isle (P_{M2isle}) at the MPP condition may be expressed as $P_{M2isle} = (\rho/t).I_{mp}^2.[1/(4.F.N^4)].2.F = (\rho/t).I_{mp}^2.[1/(2N^4)]$; as may be a total of $N \times N = N^2$ isles, total

M2 power loss at MPP may be expressed as $P_{M2loss} = (\rho/t) \cdot I_{mp}^2 \cdot [1/(2N^4)] \cdot N^2 = (\rho/t) \cdot I_{mp}^2 \cdot [1/(2N^2)]$; thus, $P_{M2loss} = (\rho/t) \cdot I_{mp}^2 \cdot [1/(2N^2)]$.

[0177] Now, as an example assuming approximately 22.5% mean solar cell efficiency $P_{mp} = 5.50$ Wp, and assume $V_{mp} = 0.59$ V, $I_{mp} = 9.3$. M2 metal layer thickness requirements for aluminum and copper – assuming a total maximum M2 allowable relative ohmic loss factor k of 0.01, 0.005, or 0.0025 (as a fraction of P_{mp} for the cell), Power Loss Factor = $k = (P_{M2loss}/P_{mp})$, K (in allowable maximum M2 loss) = $(\rho/t) \cdot (I_{mp}^2/P_{mp}) [1/(2 \cdot N^2)]$ - the required M2 metal thickness based on an allowable k at t may be expressed as $t = (\rho/k) \cdot (I_{mp}^2/P_{mp}) [1/(2 \cdot N^2)]$ where k is the maximum allowable loss as a fraction of P_{mp} .

[0178] **Table 1** below tabulates the calculated required M2 thickness for copper or aluminum M2 metallization for various allowable loss factors (k) and various N value master cell embodiments having series-connected $N \times N$ array of isles ($S = N \times N$) with the N value between 1 (for example cell with a single isle – i.e., no partitioning trenches) up to 6 (for example for $S = 36$ series connected isles) based on the expressions defined above and assuming the following: $\rho = 1.68 \mu\Omega \cdot \text{cm}$ for copper metallization, $\rho = 2.82 \mu\Omega \cdot \text{cm}$ for aluminum metallization, $P_{mp} = 5.5$ W, $I_{mp} = 9.3$ A, and allowable loss factors k of 0.01, 0.005, or 0.0025.

N	t (um) for k=0.01, Cu	t (um) for k=0.005, Cu	t (um) for k=0.0025, Cu	t (um) for k=0.01, Al	t (um) for k=0.005, Al	t (um) for k=0.0025, Al
1	13.21	26.42	52.84	22.17	44.35	88.69
2	3.30	6.60	13.21	5.54	11.09	22.17
3	1.47	2.94	5.87	2.46	4.93	9.85
4	0.83	1.65	3.30	1.39	2.77	5.54
5	0.53	1.06	2.11	0.89	1.77	3.55
6	0.37	0.73	1.47	0.62	1.23	2.46

Table 1.

[0179] Thus, patterned M2 metal layer thickness (for instance, when formed using PVD such as evaporation or sputtering) may be limited to less than approximately 5 μm , and in some instances M2 PVD metal layer thickness limited to less than approximately 3 μm , providing numerous economical (for example, reduced PVD material cost and processing simplification) as well as fabrication advantages.

[0180] In some instances, electron-beam evaporation or thermal evaporation or DC Magnetron Plasma Sputtering (a Physical-Vapor Deposition or PVD process) may be used to deposit a high-quality M2 metal layer with near-bulk material resistivity (for example with metal resistivity close to the bulk resistivity values of 1.68 $\mu\Omega\cdot\text{cm}$ for copper or 2.82 $\mu\Omega\cdot\text{cm}$ for aluminum) using high-throughput, in-line, evaporation and/or plasma sputtering tools commercially available for high-productivity solar PV applications. For example, an in-line evaporation and/or DC magnetron plasma sputtering (PVD) tool for aluminum M2 sputter deposition may have the following stations: (i) Argon plasma sputter etch to clean laser-drilled through-backplane vias, for low M2-M1 via plug contact resistance and for improved metal adhesion to the backplane; (ii) electron-beam evaporation or thermal evaporation or DC magnetron sputtering of pure aluminum, M2 layer thickness may be based on loss factor design rules, for instance, 3 to 5 microns of aluminum; (iii) DC magnetron sputtering of a thin, for example a layer thickness in the range of approximately 0.05 μm to 0.25 μm , of NiV or Ni capping layer; and (iv) DC magnetron sputtering of Sn, a Sn alloy, or alternative suitable solder material, with a layer thickness of approximately 0.5 μm to several μm .

[0181] Alternatively, an in-line DC magnetron plasma sputtering (PVD) tool for copper M2 sputter deposition may have the following stations: (i) Argon plasma sputter etch to clean M1 contact areas exposed through laser-drilled backplane via holes, for low M2-M1 via plug contact resistance and improved M2 adhesion to the backplane; (ii) DC magnetron sputtering of a thin, for example a layer thickness in the range approximately 0.05 μm to 0.25 μm , of NiV or Ni as a diffusion barrier and adhesion layer; (iii) DC magnetron sputtering of pure copper, copper thickness may be based on loss factor design rules; and (iv) DC magnetron sputtering of Sn, a Sn alloy, or alternative suitable solder material, with a layer thickness of approximately 0.5 μm to several μm .

[0182] In some embodiments, N may be chosen in order to meet particular design criteria for a given desired loss factor k and corresponding maximum allowable M2 thickness value. And by keeping the M2 copper or aluminum thickness less than about 5 μm , M2 may be easily patterned using pulsed laser ablation.

[0183] And while DC magnetron plasma sputtering of aluminum or copper, as well as any applicable barrier and/or capping layers, followed by laser ablation patterning may be used to form the M2 metal layer, alternative M2 metal layer formation methods include, but are not limited to: PVD aluminum or copper (as well as any applicable barrier and/or capping layers) followed by wet patterning (screen print mask, wet etch metal / strip mask); screen print high-conductivity, low-temperature-cure metal paste such as high-conductivity silver paste, copper paste, aluminum paste, etc.

[0184] Using aluminum as compared to copper for M2 may allow the cell fabrication line and the resulting cell to be free of copper and in some instances cell fabrication using all dry processing. Thus, improving risk mitigation in cell fabrication (due to inherent complications involved in copper processing such as with copper plating) and for the cell modules in the field as the long-term reliability concerns of copper contamination and lifetime degradation are eliminated. Moreover, the M2-M1 contact (the metallization in the via holes, or via plugs) may be an aluminum-to-aluminum contact thus eliminating the need for a diffusion barrier layer between M2 and M1. Further, an M2 Sn/NiV/Al stack or another suitable metal stack comprising aluminum as the main M2 conductor metal may allow for pulsed laser ablation patterning, thus providing all-dry cell backend metallization process and increasing cell yield.

[0185] In some embodiments, a monolithic isled master cell or icell may integrate monolithically-integrated bypass switch (MIBS) with each icell and/or with each isle in the icell to provide high-performance lightweight, thin-format, flexible, high-efficiency (e.g., greater than 20%) solar modules with distributed shade management - for example a pn junction diode, such as a rim pn junction diode, formed around the periphery of each isle. Alternatively, the MIBS device may be a metal-contact Schottky diode, such as a rim Schottky diode formed around the periphery of each isle made of, for example, an aluminum or aluminum-silicon alloy Schottky contact on n-type silicon. The pn junction MIBS diode pattern may be one of many possible pattern designs. For instance, in one

MIBS diode pattern the rim diode p+ emitter region is a continuous closed-loop band sandwiched between (or surrounded by) the n-type base regions.

[0186] While standard rigid glass modules (for instance, using copper-plated cells and discrete shade management components) may be used to reduce module manufacturing costs for isled solar cells (icells), further weight and cost reductions may be achieved by incorporating MIBS, eliminating copper plating and the discrete bypass diode components. MIBS integration benefits for a monolithic isled master cell include materials cost reductions combined with substantial manufacturing risk mitigation and higher manufacturing yield due to process simplification (no plating, much reduced cracks) and enhanced overall projected reliability (for example by eliminating the discrete components from cells). Thus, a monolithic isled MIBS integrated master cell module may reduce the weight, reduce the volume/size (and thickness), and increase power density (W/kg) of the module by significant factors – further reducing installed system Balance of System (BOS) costs.

[0187] A monolithic isled MIBS integrated master cell module may provide some or all of the following advantages: distributed MIBS shade management without external components; a relatively small average module weight per unit area, for instance, on the order of approximately 1.2 kg/m² (~0.25 lb/ft²), which may be at least 10x lighter than the standard rigid c-Si modules; module power density of approximately 155 W/kg (~70 W/lb), which is at least 10x higher than the standard rigid c-Si modules; high-efficiency (greater than 20%) lightweight flexible modules for various applications; module shipping weight and volume (per MW shipped) reductions by approximately 10x and 40x, respectively; reduced overall BOS cost, enabling a lower installed PV system cost compared to installed PV system costs using standard rigid c-Si modules; and reduced BOS and miscellaneous costs relating to shipping and handling, labor, mounting hardware, and wiring costs.

[0188] MIBS formation may be integrated and performed concurrent with partitioning trench isolation formation processing. If a rim diode design is utilized, the monolithically integrated bypass switch (MIBS) rim may also provide the additional benefit of mitigating or eliminating the generation and/or propagation of micro-cracks in the solar cell during and/or after fabrication of the solar cells.

[0189] A full-periphery through-silicon partitioning trench separating and isolating the rim bypass diode from the isles may have, for example, an isolation width in the range of a few microns up to about 100 microns depending on the laser beam diameter (or capability of the trenching process if using a process other than laser trenching) and semiconductor layer thickness. A typical trench isolation width formed by pulsed nanoseconds (ns) laser scribing may be around 20 to 50 microns although the trench isolation width may be smaller. While pulsed laser ablation or scribing is an effective and proven method to form the trench isolation regions, it should be noted that other non-mechanical and mechanical scribing techniques may also be used instead of laser scribing to form the trench isolation regions for all trench formation processing. Alternative non-laser methods include plasma scribing, ultrasonic or acoustic drilling/scribing, water jet drilling/scribing, or other mechanical scribing methods.

[0190] **Fig. 16A** is a schematic diagram showing a sunnyside view of isled master cell with a plurality of isles (example shows 4 x 4 isles) and monolithically-integrated bypass switch or MIBS devices integrated with the isles. This is an embodiment of MIBS using full-periphery bypass diodes isolated from the solar cells using full-periphery isolation trenches for an icell sharing a continuous backplane.

[0191] **Fig. 16A** is a schematic diagram showing a sunnyside plan view of isled MIBS (Monolithically Integrated Bypass Switch) master cell **270** (icell embodiment shown with 4 x 4 array of square-shaped isles) with a plurality of full-periphery closed loop MIBS bypass diodes, for example MIBS bypass diode **272** electrically isolated from isle I_{11} by isle partitioning isolation trench **274**. Each isle (I_{11} through I_{44}) is isolated by full-periphery partitioning trenches (either formed by laser ablation / scribing or scribed by another suitable technique as described above), such as cell isolation trenches **276**, to form an icell with a 4 x 4 array of isles (a solar cell comprising a plurality of mini-cells or isles) sharing a shared continuous backplane and formed from a common originally continuous and subsequently partitioned solar cell semiconductor substrate.

[0192] **Fig. 16A** shows the sunnyside view of the MIBS-enabled solar cell (icell) with mini-cells or isles and full-periphery closed-loop rim diodes (either pn junction diodes or Schottky barrier diodes). Each mini-cell isle I_{11} through I_{44} has a corresponding full periphery isolation trench (**276**) and full-periphery MIBS rim diode (such as MIBS

bypass diode **272** and periphery isolation trench **274** for cell I_{11}) – thus each mini cell or isle has a corresponding MIBS rim diode, or in other words there is one MIBS rim diode per isle or mini cell. The isles or mini-cells may be electrically connected in series through the cell metallization pattern design although other connections such as parallel or a hybrid combination of series and parallel are also possible.

[0193] As a representative example, **Fig. 16A** shows a 4 x 4 array of equally sized and shaped mini-cells and each mini-cell having a corresponding full-periphery closed-loop rim diode. In general, this architecture may use $N \times N$ array of mini-cells and corresponding full-periphery closed-loop rim diodes with N being an integer equal to or greater than two to form mini-cell array. And while **Fig. 16** shows a symmetrical $N \times N$ mini-cell array for a full-square-shaped solar cell, the mini-cell or isle array design may have an asymmetrical array of $N \times M$ mini-cells. The mini-cells or isles may be square-shaped (when $N = M$ for a square-shaped master cell) or rectangular (when N is not equal to M and/or the master cell is rectangular instead of square shaped), or various other geometrical shapes.

[0194] Further, the mini-cells of a master cell (again, a master cell refers to an array of mini-cells or isles sharing a common continuous backplane and all originating from the same original solar cell semiconductor substrate subsequently partitioned into the plurality of mini-cell or isle regions by partitioning trenches) may optionally have substantially equal areas although this is not required. The semiconductor layers for the array of isles or mini-cells are electrically isolated from each other using partitioning trench isolation formed by a suitable scribing technique such as laser scribing or plasma scribing. Moreover, each mini-cell or isle semiconductor substrate is partitioned and isolated from its corresponding full-periphery closed-loop MIBS diode semiconductor substrate using trench isolation. All the trench isolation regions on the master cell may be formed during the same manufacturing process step, for example using a single laser-scribe process step during the cell fabrication process flow.

[0195] **Figs. 16B** and **16C** are cross-sectional diagrams detailing MIBS rim or full-periphery diode solar cell embodiments of the back-contact/back-junction solar cell for one isle (or unit cell such as I_{11} in **Fig. 16A**) on a shared continuous backplane **288** after completion of manufacturing processes to form a MIBS-enabled back-contact/back-

junction isled master cell such as that shown in **Fig. 16A**, including frontside passivation and ARC coating on the textured surface of the solar cell (and MIBS device) shown as passivation/ARC coating layer **280** in the solar cell in the MIBS device. The solar cell isle and MIBS structural details such as the patterned M1 and M2 metallization layers are not shown here. **Fig. 16B** shows a MIBS implementation using a pn junction peripheral rim diode bypass switch. Trench-isolated MIBS rim pn junction diode region **282** (isolated from isle I_{11} by corresponding isolation trench **274**) comprises an n-doped (e.g., phosphorus doped) region and a p⁺ doped (e.g., heavily boron doped) region and is used as a pn junction diode bypass switch. MIBS rim pn junction diode region **282** may be a full peripheral rim diode, for example with a width in the range of about 200 to 600 microns (smaller or larger dimensions are also possible as described earlier). The MIBS rim diode and solar cell relative dimensions are not shown to scale. In one fabrication embodiment, **Fig. 16B** shows a backplane-laminated (or backplane-attached) MIBS-enabled solar cell after completion of manufacturing processes for a MIBS-enabled back-contact/back-junction (IBC) solar cell comprising completion of back-contact/back-junction cell processing through patterned first-level metallization or M1 (for example made of screen printed or PVD aluminum or aluminum-silicon alloy or another suitable metal comprising nickel, etc.), backplane lamination, epitaxial silicon lift-off release and separation from a crystalline silicon reusable template (if using an epitaxial silicon lift-off process to form the substrate – this process not applicable when using a starting crystalline silicon wafer), formation of trench isolation regions (e.g., by pulsed laser scribing or cutting) to define the MIBS rim diode border, optional silicon etch, texture and post-texture clean, passivation & ARC deposition (e.g., by PECVD or a combination of ALD and PECVD), and fabrication of the final patterned second-level metal or M2 (along with the conductive via plugs) on the backplane.

[0196] As can be seen in **Fig. 16B**, the process used to form the p⁺ emitter regions (field emitter regions and/or heavily doped emitter contact regions) of the solar cell may also be used to form p⁺ junction doping for the MIBS pn junction formation. The patterned M1 metal (not shown), for example made of aluminum or an aluminum alloy such as aluminum with some silicon addition, not only provides the contact metallization or the first-level metallization for the solar cell but also creates metallization contacts (to both

the p⁺ region and the n-type substrate region through n⁺ doped contact windows) for the MIBS pn junction diode. The n-doped silicon region of the MIBS pn junction diode is formed from the same n-type silicon substrate which also serves as the base region of the solar cell (e.g., from the n-type silicon wafer when using starting n-type crystalline silicon wafers without epitaxy, or from in-situ-doped n-type crystalline silicon layer formed by epitaxial deposition when using epitaxial silicon lift-off processing to form the solar cell and MIBS substrate) – the substrate bulk region doping may also be referred to as the background doping of the substrate. The patterned M1 and M2 metallization structures complete the required monolithic solar cell and MIBS pn junction diode electrical interconnections and also ensure the MIBS diode terminals are properly interconnected to the respective solar cell base and emitter terminals to provide cell-level integrated shade management and continual solar cell protection against shading. As can be seen in **Fig. 16B**, the sidewall edges and the top surface of the MIBS pn junction diode are also passivated using the same passivation layer(s) and processes used to passivate the sunny-side and edges of the solar cell, passivation/ARC coating layer(s) **280**. **Fig. 16A** does not show some details of the solar cell and MIBS structure such as the patterned M1 and M2 metallization, rear side passivation layer, M1 contact holes, M1-M2 via holes through the backplane, and the n⁺ doped contact windows for n-type substrate M1 connections in the MIBS device structures.

[0197] **Fig. 16C** shows a MIBS implementation using a peripheral Schottky rim diode bypass switch. Isolated Schottky rim diode bypass switch region **286** (isolated from isle I₁₁ by corresponding isolation trench **274**) comprises an n-doped region and an inner and outer n⁺ region and is used as a Schottky diode bypass switch. Schottky rim diode bypass switch region **286** may be a full peripheral rim diode with a width in the range of 200 to 600 microns (this dimension may be chosen to be larger or smaller than this range).

[0198] In one fabrication embodiment, **Fig. 16C** shows a backplane-laminated or backplane-attached MIBS-enabled solar cell after completion of manufacturing processes for the MIBS-enabled back-contact/back-junction isled master cell comprising completion of the back-contact/back-junction cell processing through a patterned first-level metallization or M1 (for example made of a suitable conductor which can serve as both an effective ohmic contact on heavily doped silicon as well as an effective Schottky

barrier contact on lightly doped silicon, such as aluminum or aluminum-silicon alloy), backplane lamination, epitaxial silicon lift-off release and separation from a crystalline silicon reusable template when using an epitaxial lift off silicon substrate (this process not applicable or required when using starting crystalline silicon wafers instead of epitaxial lift off substrates), formation of the trench isolation (e.g., by pulsed laser scribing or cutting) to define MIBS rim Schottky diode border, optional silicon thinning etch, texture and post-texture clean, formation of passivation and ARC (e.g., by PECVD or a combination of PECVD with another process such as ALD), and fabrication of a final patterned second-level metal or M2 on the backplane (in conjunction with the conductive M1-M2 via plugs).

[0199] As can be seen in **Fig. 16C**, the n-type silicon substrate also used as the base region of the solar cell (for instance formed through in-situ-doped epitaxial deposition when using epitaxial lift off processing, or from a starting n-type crystalline silicon wafer when not using epitaxial lift off processing) is also used as the n-type silicon substrate region for the MIBS Schottky diode. The M1 metal (not shown), for example made of aluminum or a suitable aluminum alloy such as aluminum with some silicon addition, not only makes the M1 ohmic contact metallization for the solar cell (for both base region through n⁺ doped contact openings and emitter contact region through p⁺ doped contact openings of the solar cell), but also creates the metallization contacts for the MIBS Schottky diode (both the non-ohmic Schottky barrier contact on the lightly doped n-type silicon substrate region and the ohmic contact to n-type silicon through heavily doped n⁺ doped regions). The lightly doped n-type silicon substrate region of the MIBS diode is from the same n-type substrate used for the solar cell and serving as its base region (e.g., the n-type substrate may be formed by in-situ-doped n-type epitaxial silicon deposition when using epitaxial silicon lift-off processing, or from a starting n-type crystalline silicon wafer when not using epitaxial silicon lift off processing). The heavily doped n⁺ diffusion doping of the n-type silicon region for the MIBS Schottky diode ohmic contacts to the n-type silicon substrate may be formed at the same time and using the same process also used for producing the heavily doped n⁺ doped base contact regions for the solar cell (in preparation for the subsequent patterned M1 metallization). The combination of patterned M1 and M2 metallization structures complete the solar cell and MIBS Schottky

diode electrical interconnections and ensure the MIBS diode terminals are properly connected to the solar cell terminals to provide cell-level integrated shade management and solar cell protection. As can be seen **Fig. 16C**, the sidewall edges and the top surface of the MIBS Schottky diode are also passivated using the same passivation and ARC layer(s) and process(es) used to form the passivation and ARC layer(s) on the sunny-side and edges of the solar cell - note passivation/ARC coating layer(s) **280**. Again, **Fig. 16C** does not show some structural details of the solar cell structure including but not limited to the patterned M1 and M2 metallization layers.

[0200] The monolithically isled solar cells, and optionally MIBS embodiments, disclosed herein employ trench isolation in conjunction with a shared backplane substrate to establish partitioning and electrical isolation between the semiconductor substrate regions (isles) and also optionally for the MIBS device and adjacent isles or solar cell region. One method to create the trench isolation regions is pulsed (such as pulsed nanoseconds) laser scribing. Below is a summary of key considerations and laser attributes for using a laser scribing process to form the trench isolation regions which partition and electrically isolate substrate region(s).

[0201] Pulsed laser scribing for trench isolation formation may use a pulsed nanoseconds (ns) laser source at a suitable wavelength (e.g., green, or infrared or another suitable wavelength to ablate the semiconductor layer with relatively good selectivity to cut through the semiconductor substrate layer with respect to the backplane material) commonly used and proven for scribing and cutting through silicon. The laser source may have a flat-top (also known as top-hat) or a non-flat-top (e.g., Gaussian) laser beam profile. It's possible to use a pulsed laser source wavelength which is highly absorptive in silicon but can partially or fully transmit through the backplane (hence, cut through the semiconductor layer without substantially removing the backplane material after the through-semiconductor layer laser cutting is complete and the beam reaches the backplane sheet). For instance, we may use a pulsed nanoseconds IR or green laser beam which may effectively cut through the silicon substrate layer and partially transmit through the backplane material (hence, removing little to negligible amount of backplane material during the trench isolation cut).

[0202] The pulsed laser beam diameter and other properties of the pulsed nanoseconds laser source may be chosen such that the isolation scribe width is in the range of a few microns up to 10's of microns as a width much larger than about 100 microns would be rather excessive and result in unnecessary waste of precious silicon substrate area and some reduction of the total-area efficiency of the solar cells and modules. Thus, it is beneficial to minimize the trench isolation areas as compared to the highly desirable solar cell area. In practice, pulsed nanoseconds laser cutting can produce trench isolation regions with width in the desirable range of about 20 microns up to about 60 microns. For instance, for a 156 mm x 156 mm solar cell, a trench isolation width of 30 microns corresponds to an area ratio of 0.077% for the trench isolation area as a fraction of the cell area. This represents a rather negligible area compared to the solar cell area, in other words, this small ratio provides negligible waste of solar cell area and ensures negligible loss of total-area solar cell and module efficiency.

[0203] Pulsed nanoseconds (ns) laser scribing or cutting to form trench isolation may be performed immediately after the backplane lamination process when using starting crystalline silicon wafers to fabricate the solar cells (and in the case of solar cells using epitaxial silicon lift-off processing, after completion of the backplane lamination process and subsequent lift-off release of the laminated cell from the reusable template and after or before pulsed laser trimming of the solar cell) in a back-contact/back-junction solar cell fabrication process as described herein. In the case of solar cells fabricated using epitaxial silicon lift-off processing, the trench isolation scribing or cutting process may optionally use the same pulsed laser tool and source used for pre-release scribing of the epitaxial silicon layer to define the lift-off release boundary and/or used for post-release trimming of the laminated solar cell. Thus, no additional laser process tool may be needed in order to form the trench isolation regions.

[0204] Pulsed nanoseconds (ns) laser scribing to form trench isolation may also be used to partition the isles and define the fully isolated MIBS rim diode region outside an isolated solar cell island surrounded by and defined by the rim. Alternatively, the pulsed ns laser scribing process may form other designs of the MIBS diode, such as in a multiple MIBS diode island design as well as and many other possible MIBS pattern designs.

[0205] Pulsed laser scribing may be used to cut through the thin (such as sub-200 microns and more particularly sub-100 microns) silicon substrate layer (from the sunny side) and substantially stop on the backplane material sheet. If desired and/or required, a simple real-time in-situ laser scribe process end-pointing, such as using reflectance monitoring, may be used for process control and endpointing to minimize trenching or material removal in the backplane sheet while enabling complete through-semiconductor-layer laser cut.

[0206] The sidewalls of the solar cell and the MIBS rim diode regions may be subsequently wet etched (for instance, as part of the solar cell sunny-side wet etch / texture process), post-texture cleaned, and passivated (by deposition of the passivation and ARC layer) during the remaining solar cell fabrication process steps.

[0207] The MIBS diode may be a pn junction diode used as the MIBS bypass device or shade management switch. A pn junction MIBS diode fabrication process to produce a MIBS-enabled solar cell of may have the following, among others, attributes and benefits:

- In some solar cell processing designs, there may be essentially no change (or minimal change) to the main solar cell fabrication process flow to implement MIBS (for example a back-junction/back-contact crystalline silicon solar cell fabrication using either crystalline silicon starting wafers or epitaxial silicon and porous silicon/lift-off processing in conjunction with a reusable crystalline silicon template, and an electrically insulating backplane). Thus, there may be essentially no added processing cost to implement MIBS along with the solar cells (icells) disclosed herein.
- In a back-contact/back-junction epitaxial silicon lift-off cell process, following the completion of the on-template cell processing involving most of the back-contact, back-junction cell process steps, the following processes may be performed (provided as an example of various possible process flows): (i) backplane lamination to the solar cell backside; (ii) pre-release trench scribe (for example using a pulsed nanoseconds laser scribe tool or alternatively using another scribing tool such as plasma scribe) of the thin epitaxial silicon substrate to define the epitaxial silicon lift-off release boundary; (iii) mechanical lift-off release of

the backplane-supported cell and its detachment from the reusable crystalline silicon template; (iv) laser trim (for example using a pulsed nanoseconds laser source) of the backplane-laminated cell for precision trim and to establish the final desired dimensions for the solar cell in conjunction with its associated MIBS; (v) pulsed nanoseconds laser scribing (or plasma scribing or another suitable scribing technique) on the sunny-side of the solar cell to form the trench isolation region(s) and to define the inner solar cell island(s) and the peripheral rim diode(s) regions, this step providing the isles and corresponding MIBS regions; (vi) and, subsequent cell processing such as sunny-side texture and post-texture clean followed by additional cell process steps such as PECVD sunny-side passivation and anti-reflection coating (ARC) layer deposition and final cell metallization including patterned second level metallization if applicable. When using starting crystalline silicon wafer instead of epitaxial silicon lift-off processing, the process flow is fairly similar to the flow described above, except that there is no reusable template, porous silicon, epitaxial silicon, or release process. In the process flow described above for the solar cells made using epitaxial silicon lift-off processing, the trench isolation scribing process and tool may be essentially the same as the process and tool used for pre-release trench scribe and/or the post-release precision trim of the backplane-laminated solar cell and MIBS substrate.

- The laser scribed trench isolation process may be performed (for example using a pulsed nanoseconds laser source) to create complete through-semiconductor trench(es) within the semiconductor layer through the entire thickness of the crystalline silicon layer and substantially stopping at the backplane - thus forming the electrically isolated n-type silicon rim region for the MIBS diode and the n-type silicon island region for solar cell assuming an n-type base and p⁺ emitter solar cell (a common doping type for a back-contact/back-junction IBC solar cell).

[0208] In an all-series-connected cell, an M2 cell metallization design which results in sufficiently low or negligible ohmic losses should be used due to the current flow on lateral M2 connectors between the adjacent series-connected columns. Lateral M2

jumpers or connectors (which may be formed in conjunction with the patterned M2 layer) are used to interconnect the adjacent columns of icell in electrical series.

[0209] As shown in **Fig. 17**, all-series-connected icell or master cell **300** has an $N \times N$ array (N rows and N columns, shown as 4×4 in this representative example) of electrical series-connected isles I_{11} through I_{44} (isles defined by outer cell boundary **302** and electrical isolation trenches **304**) from emitter busbar **308** to base busbar **310**, each isle in a column electrically connected by M2 series connections **306** (simply shown as arrows) and each column in series electrically connected by lateral M2 jumpers **312**. Master cell **300** has N columns (in this embodiment $N = 4$) and $N-1$ lateral M2 jumpers **312** ($N-1 = 3$) each with a length of $2H$ and width of W . A lateral M2 jumper half-segment has a length of H (with H being the side dimension of each square-shaped isle) and width of W . M2 metallization pattern is not shown in **Fig. 17**; however an M2 unit cell such as that shown in **Fig. 13** may correspond to each isle (I_{11} through I_{44}).

[0210] Assuming an M2 metal layer thickness of t and a resistivity of ρ (or a sheet resistance of ρ/t). And assuming the master square cell has a side dimension of $L = N.H$, an area of L^2 , a maximum power of P_{mp} , and a non-isled (non-tiled) maximum-power-point (MPP) current of I_{mp} (in other words the MPP for a single isle cell – for an isled master cell with all-series-connected isles, the MPP current is scaled down by N^2). And assuming for an isled master cell having $N \times N$ series-connected isles, assume P_s is the ohmic power loss per half-segment of a lateral M2 jumper, and P_l is the total ohmic power loss for all the lateral M2 jumper segments, thus $P_l = 2(N-1).P_s$. The inter-columnar current flow ohmic losses in an all-series connected $N \times N$ master cell may be calculated as follows: $P_s = \text{Integral from 0 to } H \text{ of } \{[(\rho.dx).(W.t)].(I_{mp}/N^2).(x/H)]^2\}$; thus $P_s = [\rho/(W.t)].[I_{mp}/(N^2.H)]^2. \{ \text{Integral from 0 to } H \text{ of } [x^2.dx] \}$; thus $P_s = [\rho/(W.t)].[I_{mp}/(N^2.H)]^2.(H^3/3) = (1/3).[(\rho.H)/(W.t)].(I_{mp}/N^2)^2$; since $P_l = 2(N-1).P_s$ then $P_l = [2(N-1)/3].[(\rho.H)/(W.t)].(I_{mp}/N^2)^2$; and since $H = L/N$ then $P_l = [2(N-1)/3].[(\rho.L)/(N.W.t)].(I_{mp}/N^2)^2$; thus $P_l = [2(N-1)/(3.N^5)].[(\rho.L)/(W.t)].I_{mp}^2$. The total lateral M2 jumper power loss factor (ratio) is defined as $k_j = P_l / P_{mp}$.

[0211] Now, assuming a solar cell having approximately 22.5% mean cell efficiency and $P_{mp} = 5.50 \text{ Wp}$ and assuming $V_{mp} = 0.59 \text{ V}$, $I_{mp} = 9.3 \text{ A}$, M2 metal thickness requirements for aluminum and copper may be calculated as describe herein assuming an

allowable maximum total lateral M2 jumper power loss factor (ratio) of 0.01, 0.005, or 0.0025 (as a fraction of P_{mp} for the cell). Power Loss Factor = $k_j = (P_l/P_{mp})$ and K_j (in allowable maximum M2 loss) = $[2(N-1)/(3.N^5)].[(\rho.L)/(W.t)].(I_{mp}^2/P_{mp})$.

[0212] Thus, required lateral M2 jumper width W and/or the M2 metal thickness t based on an allowable k_j may be expressed as $W.t = [2(N-1)/(3.N^5)].(\rho.L).(I_{mp}^2/P_{mp})/k_j$ where k_j is the maximum allowable total lateral M2 jumper ohmic loss as a fraction of P_{mp} .

[0213] **Tables 2** through **7** below show calculated M2 lateral jumper $W.t$ and W values for aluminum with bulk resistivity of $\rho = 2.82 \mu\Omega.cm$ (**Tables 2** through **4**) and copper with bulk resistivity of $\rho = 1.68 \mu\Omega.cm$ (**Tables 5** through **7**) for various allowable loss factors (k_j) and the N value between 3 and 5, and $L=156$ mm.

N and k_j Values	N=3	N=4	N=5
$k_j = 0.0025$	1.52E-03 cm ²	5.40E-04 cm ²	2.36E-04 cm ²
$k_j = 0.0050$	7.59E-04 cm ²	2.70E-04 cm ²	1.18E-04 cm ²
$k_j = 0.0100$	3.80E-04 cm ²	1.35E-04 cm ²	5.90E-05 cm ²

Table 2. Calculated $W.t$ Values (in cm²) With Aluminum M2 Metallization.

N and k_j Values	N=3	N=4	N=5
$k_j = 0.0025$	5.061 cm	1.802 cm	0.787 cm
$k_j = 0.0050$	2.531 cm	0.901 cm	0.394 cm
$k_j = 0.0100$	1.265 cm	0.450 cm	0.197 cm

Table 3. Calculated W Values (in cm) With Aluminum M2 Metallization and $t = 3 \mu m$ Al.

N and k_j Values	N=3	N=4	N=5
$k_j = 0.0025$	3.037 cm	1.081 cm	0.472 cm
$k_j = 0.0050$	1.518 cm	0.540 cm	0.236 cm
$k_j = 0.0100$	0.759 cm	0.270 cm	0.118 cm

Table 4. Calculated W Values (in cm) With Aluminum M2 Metallization and $t = 5 \mu m$ Al.

N and k_j Values	N=3	N=4	N=5
$k_j = 0.0025$	9.05E-04 cm ²	3.22E-04 cm ²	1.41E-04 cm ²
$k_j = 0.0050$	4.52E-04 cm ²	1.61E-04 cm ²	7.03E-05 cm ²
$k_j = 0.0100$	2.26E-04 cm ²	8.05E-05 cm ²	3.52E-05 cm ²

Table 5. Calculated W.t Values (in cm²) With Copper M2 Metallization.

N and k_j Values	N=3	N=4	N=5
$k_j = 0.0025$	3.015 cm	1.073 cm	0.469 cm
$k_j = 0.0050$	1.508 cm	0.537 cm	0.234 cm
$k_j = 0.0100$	0.754 cm	0.268 cm	0.117 cm

Table 6. Calculated W Values (in cm) With Copper M2 Metallization and $t = 3 \mu\text{m}$ Cu..

N and k_j Values	N=3	N=4	N=5
$k_j = 0.0025$	1.809 cm	0.644 cm	0.281 cm
$k_j = 0.0050$	0.905 cm	0.322 cm	0.141 cm
$k_j = 0.0100$	0.452 cm	0.161 cm	0.070 cm

Table 7. Calculated W Values (in cm) With Copper M2 Metallization and $t = 5 \mu\text{m}$ Cu.

[0214] Based on the exemplary calculations above, the following regarding ohmic losses of M2 lateral jumpers between adjacent isle columns may be concluded:

- Practical and optimum M2 designs with sufficient lateral M2 jumper width can be provided in order to limit the total lateral M2 jumper ohmic power loss to less than about 1% (or as low as less than 0.5%) relative, without a need for soldering external copper ribbon tabs on the lateral M2 jumpers between the isle columns;
- For a given M2 metal thickness, the total lateral M2 jumper ohmic power loss is reduced for higher values of N and/or lower resistivity metal;
- For either aluminum or copper M2 metallization in an isled cell design with N=4, the M2 jumper width may be limited to less than 1 cm for M2 metal thickness of either 3 μm or 5 μm (or any width approximately in this range) while maintaining the maximum total lateral M2 jumper power loss to no more than about 0.50%

relative ohmic losses - corresponding to approximately 0.1% absolute cell efficiency loss due to the M2 jumpers; and

- The ability to limit the maximum lateral M2 jumper ohmic losses to well below 1% relative while using an M2 metal (aluminum or copper) thickness of no more than 5 μm , or 3 μm , with lateral jumper width of less than 1 cm provides for the formation of high-performance, low-loss M2 metallization without a need for externally soldered copper ribbon tabs on the lateral M2 jumpers. Thus enabling the production of low-cost, reliable isled cells without a need for excessively large value of N. In other words N=4 is sufficient (in an $N \times N = 4 \times 4$ icell design) and in some instances N=5 may be more advantageous since it provides even lower losses.

[0215] As noted, isles (designed in any shape) may be electrically connected in an all-series, an all-parallel, or a hybrid series-parallel M2 interconnection design. The M2 interconnection pattern should maintain the benefits of substantially reduced $R \cdot I^2$ ohmic losses in the cell, module, and system due to the scaled up the voltage and scaled down the current of the master cell.

[0216] The following exemplary embodiments are provided to illustrate high cell efficiency (for example approximately 22% cell efficiency) interconnection designs for an evaporated aluminum M2 pattern having a layer thickness of less than approximately 5 μm compatible with both full-square and pseudo-square substrate formats.

Specifically, designs describing a master cell having a 4 x 4 array of monolithic trench isolated isles having a hybrid parallel-series isle connection design and having an all-series isle connection design with a master cell voltage of approximately close to 5 V and a current of approximately close to 1 A are provided.

[0217] It is important to note that although the isle designs are described generally as square shaped, the isles may be formed in any geometric shape in accordance with the disclosed subject matter. And in most instances, it is desirable to eliminate area-related current mismatches between the series-connected isles – in other words, to design and pattern the array of isles symmetrically to maintain equivalent area between isles or subgroups of isles connected in parallel.

[0218] Further, the M2 interconnection designs disclosed herein provide relatively optimum-range current-voltage parametrics for integration of inexpensive, embedded, high-performance distributed MPPT power optimizer and/or shade management electronics components assuming a master cell maximum-power voltage (V_{mp}) in the range of approximately ~5 V to 10 V and a master cell maximum-power current (I_{mp}) in the range of approximately ~0.5 A to 1 A.

[0219] Additionally, the M2 interconnections provided herein are capable of supporting various installed PV arrays, such as 600 VDC and 1,000 VDC PV systems for maximum system-level efficiency in residential and commercial rooftop as well as ground-mount utility-scale applications.

[0220] The following parametric assumptions are provided for a master cell or icell having an efficiency of approximately 22% with a 4 x 4 array of isles connected in parallel (referred to herein as all-parallel): Cell Power = 5.35 W_p (assumes full-square 156 mm x 156 mm master cell); V_{oc} = 685 mV, and V_{mp} = 575 mV, then V_{mp}/V_{oc} = 0.84 or 84%; I_{oc} = 9.90 A, and I_{mp} = 9.30 A, then V_{mp}/V_{oc} = 0.94 or 94%; and Fill Factor = $(V_{mp} \times I_{mp} / V_{oc} \times I_{oc})$ = 0.79 or 79%.

[0221] In an all-series 4 x 4 master cell (assuming a full-square 156 mm x 156 mm master cell) referred to herein as a 1x16S (1 by 16 Series) design, an example of which is shown in **Fig. 18A**, the following may be assumed: V_{oc} = 685 mV x 16 = 10.96 V and I_{oc} = 9.90 A / 16 = 0.619 A; V_{mp} = 575 mV x 16 = 9.20 V, and I_{mp} = 9.30 A / 16 = 0.581 A. Further, for a 60-cell module using the 1x16 all-series master cell design, module parametrics may be assumed to be: Module V_{oc} = 10.96 V x 60 = 657.6 V and Module V_{mp} = 9.20 V x 60 = 552.0 V; and I_{oc} = 0.619 A, and I_{mp} = 0.581 A.

[0222] In a hybrid parallel-series (HPS) 4 x 4 master cell with 8 series pairs of isles (assuming full-square 156 mm x 156 mm master cell) – referred to herein as a 2x8HPS (2 by 8 Hybrid Parallel Series) design, an example of which is shown in **Fig. 18B**, the following may be assumed: V_{oc} = 685 mV x 8 = 5.48 V and I_{oc} = 9.90 A / 8 = 1.238 A; V_{mp} = 575 mV x 8 = 4.60 V, and I_{mp} = 9.30 A / 8 = 1.163 A. Further, for a 60-cell module using the 2x8 hybrid master cell design, module parametrics may be assumed to be: Module V_{oc} = 5.48 V x 60 = 328.8 V, and Module V_{mp} = 4.60 V x 60 = 276.0 V; and I_{oc} = 1.238 A, and I_{mp} = 1.163 A.

[0223] **Figs. 18A, 18B, and 18C** are schematic diagrams for a full square master cell or icell showing an all-series (1x16) master cell configuration (4 x 4 array of isles) referred to herein as a 1x16S design (**Fig. 18A**), a hybrid parallel-series (2x8) master cell or icell configuration (4 x 4 array of isles) referred to herein as a 2x8HPS design (**Fig. 18B**), and a hybrid parallel-series (8x8) master cell or icell configuration (8x8 array of isles) referred to herein as a 8x8HPS design (**Fig. 18C**).

[0224] As shown in **Fig. 18A**, all-series master cell or icell configuration 1x16S **320** has an 4x4 array of electrical series-connected isles I_{11} through I_{44} from emitter busbar **322** to base busbar **324**, each isle in a column electrically connected by M2 series connections **328** and each column in series electrically connected by lateral M2 jumpers **326**.

[0225] As shown in **Fig. 18B**, hybrid parallel-series master cell configuration 2x8HPS **340** has a 4 x 4 array of electrical series and parallel connected isles I_{11} through I_{44} from emitter busbar **342** to base busbar **344**, adjacent isles in a column connected in parallel by M2 parallel connections **350** and each isle in a column electrically connected by M2 series connections **348** and combined parallel connected adjacent isles electrically connected in series by lateral M2 jumpers **346**. In some applications, the 2X8HPS design of **Fig. 18B** may be particularly suitable for a master cell having a thin silicon absorber layer (for example having a thickness in the range of about a few microns up to 100 microns).

[0226] As shown in **Fig. 18C**, hybrid parallel-series master cell configuration 8x8HPS **352** has an 8x8 array of electrical series and parallel connected isles I_{11} through I_{88} from emitter busbar **354** to base busbar **356**, adjacent isles in a column connected in parallel by M2 parallel connections and isles in a column electrically connected by M2 series connections and combined parallel connected adjacent isles electrically connected in series by lateral M2 jumper **358**. In some applications, the 8X8HPS design of **Fig. 18C** may be particularly suitable for a master cell having a somewhat thicker silicon absorber layer (for example having a silicon thickness in the range of about 50 to 150 microns). This is due to the fact that this 8x8HPS design provides a higher degree of flexibility / bendability and hence can be suitable for a wide range of silicon thicknesses (even accommodating thicker silicon for flexible crack-free solar cells). The 2x8HPS solar cell

of **Fig. 18B** and 8x8HPS solar cell of **Fig. 18C** provide the same current and voltage scaling factor of 8.

[0227] **Figs. 19A, 19B, and 19C** are diagrams showing example placement/position of a relatively small shade management bypass switch (e.g., either a pn junction diode or a Schottky barrier diode) on the M2 interconnection designs of the master cells shown in **Figs. 18A, 18B, and 18C**, respectively.

[0228] As shown in **Fig. 19A**, all-series master cell configuration 1x16S **360** has a 4 x 4 array of electrical series-connected isles I_{11} through I_{44} from emitter busbar **362** to base busbar **364**, each isle in a column electrically connected by M2 series connections **368** and each column in series electrically connected by lateral M2 jumpers **366**. Lateral M2 jumper **370** has been offset from the master cell peripheral edge for direct placement and connection of a relatively small-package bypass switch **376** to emitter busbar **362** and base busbar **364**. Busbar extensions **374** connect emitter busbar **362** and base busbar **364** to bypass switch **376**.

[0229] As shown in **Fig. 19B**, hybrid parallel-series master cell configuration 2x8HPS **380** has a 4 x 4 array of electrical series and parallel connected isles I_{11} through I_{44} from emitter busbar **382** to base busbar **384**, adjacent isles in a column connected in parallel by M2 parallel connections **390** and each isle in a column electrically connected by M2 series connections **388** and combined parallel connected adjacent isles electrically connected in series by lateral M2 jumpers **386**. Bypass switch **392** is positioned between and directly connected to emitter busbar **382** and base busbar **384**.

[0230] As shown in **Fig. 19C**, hybrid parallel-series master cell configuration 8x8HPS **394** has an 8x8 array of electrical series and parallel connected isles I_{11} through I_{88} from emitter busbar **395** to base busbar **396**, adjacent isles in a column connected in parallel by M2 parallel connections and isles in a column electrically connected by M2 series connections and combined parallel connected adjacent isles electrically connected in series by lateral M2 jumper **397**. Bypass switch **398** is positioned between and directly connected to emitter busbar **395** and base busbar **396**.

[0231] In practice, monocrystalline semiconductor wafers (particularly CZ and FZ monocrystalline silicon wafers) are often fabricated from a cylindrical ingot and most often commercially available in a circular shape. To maximize semiconductor material

usage and minimize waste, a master cell may be formed as a pseudo-square solar cell – as shown in **Fig. 20**. **Fig. 20** is a schematic diagram showing a top view of a pseudo-square shaped master cell substrate fabricated from a cylindrical ingot (shown by cylindrical ingot periphery).

[0232] Thus, to maintain symmetry and equivalently sized (equal series-connected isle areas) series connected isles or sub-groups of isles, isles within a pseudo-square shaped master cell may be individually designed in various shapes and configurations.

[0233] **Fig. 20** is a diagram showing a top view of a pseudo-square shaped master cell substrate **400** fabricated from a cylindrical ingot (shown by cylindrical ingot periphery **402**). Excluded corners **404** have area a' per corner and have been removed/excluded from the pseudo-square master cell substrate design in order to minimize the ingot waste while providing a nearly (but not full) square wafer for solar cell fabrication.

[0234] In practice and used as exemplary design dimensions herein, pseudo-square master cell substrate **400** may have dimensions of 156 mm by 156 mm ($L = 156$ mm) with a diagonal dimension of 220 mm ($D_{\text{square}} = 220$ mm) formed from a cylindrical ingot having a final polished ingot diameter of 200 mm ($D_{\text{ingot}} = 200$ mm). Assuming the dimensions described above, a full-square substrate will have an area ($A_{\text{sq}} = L^2 = 156$ mm $\times$ 156 mm = 243.36 cm²). And a pseudo-square substrate will have an area ($A_{\text{psq}} = A_{\text{sq}} - 4a'$ where $a' \approx (D_{\text{square}} - D_{\text{ingot}})^2 / 4$, then $a' \approx (220 \text{ mm} - 200 \text{ mm})^2 / 4 \approx 1 \text{ cm}^2$ and $A_{\text{psq}} \approx 243.36 - 4 \times 1 \text{ cm}^2 = 239.36 \text{ cm}^2$. Thus when $L = 156$ mm, standard pseudo-square wafers have a cell area of 239.36 cm² as compared to standard 156 mm $\times$ 156 mm square wafers having cell area of 243.36 cm² - resulting in approximately 1.64% less area ($4/243.36$).

[0235] **Fig. 21** is a diagram of a hybrid parallel-series pseudo-square master cell configuration 2x8HPS **420** having a 4 $\times$ 4 array of electrical series and parallel connected isles I_{11} through I_{44} (isles defined by isolation trenches **424**) from emitter busbar to base busbar similar to the cell shown in **Fig. 18B** (emitter busbar, base busbar, and lateral M2 jumpers not shown in **Fig. 21**). Similar to the pseudo-square master cell shown in **Fig. 20**, pseudo-square master cell **420** has a side length L (for instance, 156 mm for a 156 mm $\times$ 156 mm pseudo-square icell) and is missing corners **422** each having area a' .

[0236] The following dimensions are provided as an exemplary to fully balance the master cell current of pseudo-square master cell configuration 2x8HPS **420**; however, as noted previously the isle design principles disclosed herein may be applicable to various cell shapes and dimensions. As shown master cell **420** is horizontally and vertically symmetrical (resulting in eight pairs of parallel connected isles) and the dimensional expressions following are for one quadrant (for example I_{11} , I_{21} , I_{12} , and I_{22}). Each set of isles connected in series may be designed or sized to have an equivalent area (and a corresponding equivalent voltage and current) – in other words the area of $I_{11} + I_{12} = I_{21} + I_{22}$.

[0237] For $L=156$ mm, L_1 and L_2 may then be calculated as follows, resulting in a fully current-balanced master cell: $[(L/4).L_1 - a'] + (L/4).L_1 = 2.(L/4).L_2$ and $L_1 + L_2 = L/2$. Thus for $L = 15.6$ cm (or $L/4 = 3.9$ cm) and $a' = 1\text{cm}^2$: $3.9 L_1 - 1 + 3.9 L_1 = 2 \times 3.9 L_2$ and $L_1 + L_2 = 15.6/2$. Then $L_1 - L_2 = 0.1282\text{cm}$ and $L_1 + L_2 = 7.8\text{cm}$. Resulting in $L_1 = 3.964\text{cm}$ and $L_2 = 3.836\text{cm}$.

[0238] **Fig. 22** is a diagram of an all-series pseudo-square master cell configuration 1x16S **430** having a 4 x 4 array of electrical series connected isles I_{11} through I_{44} (isles defined by isolation trenches **434**) from emitter busbar to base busbar similar to the cell shown in **Fig. 18A** (emitter busbar, base busbar, and lateral M2 jumpers not shown in **Fig. 22**). Similar to the pseudo-square master cell shown in **Fig. 20**, pseudo-square master cell **420** has a side length L (for example 156 mm for a 156 mm 156 mm pseudo square solar cell) and is missing corners **422** each having area a' .

[0239] The following dimensions are provided as an exemplary to fully balance the master cell current of pseudo-square master cell configuration 1x16S **430** having a side length L (156 mm) with continuous isolation trenches defining each isle – in other words the guideline described provided for equal area isles. In some instances, continuous isolation trenches (trench isolation lines formed continuous with common intersection points) may be desired to maximize master cell flexibility for processing simplicity during scribing and to minimize crack generation and propagation. As shown in **Fig. 22**, all trench isolation line intersections have right angles, except for those specified otherwise.

[0240] In the isle design of **Fig. 22**, isles in the second and third columns (I_{12} , I_{22} , I_{32} , I_{42} , I_{13} , I_{23} , I_{33} , I_{43}) are rectangular, each having an area $(L/4) \cdot W_2$. Isles in the first and fourth columns are non-rectangular: isles I_{21} , I_{31} , I_{24} , and I_{34} are trapezoidal; and corner isles I_{11} , I_{41} , I_{14} , and I_{44} are polygons. The three vertical scribe lines (isolation trenches) and the central horizontal scribe line (isolation trench) are straight lines running from edge to edge of the master cell. The two outside horizontal scribe lines (isolation trenches) – in other words the top and bottom scribe lines – are straight and horizontal between the two middle columns (columns 2 and 3) and sloped by angle θ as the lines extend to the first and fourth columns. Thus, master cell **430** is horizontally and vertically symmetrical (resulting in 16 connected isles each having an equivalent area and four symmetrical quadrants). The dimensional expressions following are for one quadrant (for example I_{11} , I_{21} , I_{12} , and I_{22}). Each set of isles connected in series is designed to have an equivalent area (and a corresponding equivalent voltage and current) – in other words the area of $I_{11} = I_{22} = I_{21} = I_{12}$.

[0241] For a master cell side dimension L (156 mm) the isle dimensions of master cell **430**, may be calculated as follows: the area of isle I_{12} (same rectangular shape and area as isles I_{22} , I_{32} , I_{42} , I_{13} , I_{23} , I_{33} , I_{43}) = $A_{\text{rectangle}} = W_2 \cdot (L/4)$; the area of isle I_{11} (same polygonal shape and area as Isles I_{41} , I_{14} , I_{44}) = $A_{\text{corner}} = W_1 \cdot (L/4) + [W_1^2 / \tan(\theta)]/2 - a'$; the area of isle I_{21} (same trapezoidal shape and area as isles I_{31} , I_{24} , I_{34}) = $A_{\text{trapezoid}} = W_1 \cdot (L/4) - [W_1^2 / \tan(\theta)]/2$. And $A_{\text{rectangle}} = A_{\text{corner}} = A_{\text{trapezoid}} = (L^2 - 4 \cdot a')/16$, thus $W_2 \cdot (L/4) = W_1 \cdot (L/4) + [W_1^2 / \tan(\theta)]/2 - a' = W_1 \cdot (L/4) - [W_1^2 / \tan(\theta)]/2 = (L^2 - 4 \cdot a')/16 = (15.6 \text{ cm} \times 15.6 \text{ cm} - 4.0 \text{ cm}^2)/16 = 14.96 \text{ cm}^2$. Each isle has an area of 14.96 cm^2 .

[0242] Then $W_2 \cdot (L/4) = 14.96 \text{ cm}^2$, $W_2 \cdot L = 59.84 \text{ cm}^2$, $W_2 = 59.84/15.6 \text{ cm}$, thus $W_2 = 3.836 \text{ cm}$. And $W_1 \cdot (L/4) + [W_1^2 / \tan(\theta)]/2 - a = 14.96 \text{ cm}^2$, $W_1 \cdot L + 2[W_1^2 / \tan(\theta)] = 63.84 \text{ cm}^2$, $W_1 \cdot (L/4) - [W_1^2 / \tan(\theta)]/2 = 14.96 \text{ cm}^2$, and $W_1 \cdot L - 2[W_1^2 / \tan(\theta)] = 59.84 \text{ cm}^2$. Therefore: $2W_1 \cdot L = 63.84 + 59.84 \text{ cm}^2 = 123.68 \text{ cm}^2$, $W_1 = 123.68/(2 \times 15.6) \text{ cm}$, thus $W_1 = 3.964 \text{ cm}$. And $4[W_1^2 / \tan(\theta)] = 63.84 - 59.84 \text{ cm}^2$, $4[3.964^2 / \tan(\theta)] = 4.00 \text{ cm}^2$, $\tan(\theta) = 15.7133$, thus $\theta = 86.36^\circ$. And $L_T = L/4 - W_1/\tan(\theta) = 15.6/4 - 3.964/15.7133$, $L_T = 3.9 - 0.252 \text{ cm}$, thus $L_T = 3.648 \text{ cm}$.

[0243] Thus, in the exemplary embodiment providing dimensions and angles for current matching in the 1x16S all-series 4x4 pseudo-square substrate master cell of **Fig. 22**: each

isle area = 14.96 cm^2 , Polygonal Isles (4 Corners): Isles I_{11} , I_{41} , I_{14} , and I_{44} ; Trapezoidal Isles (4): Isles I_{21} , I_{31} , I_{24} , and I_{34} ; Rectangular Isles (8 Middle): I_{12} , I_{22} , I_{32} , I_{42} , I_{13} , I_{23} , I_{33} , I_{43} ; $L/4 = 39.00 \text{ mm}$; $W_2 = 38.36 \text{ mm}$; $W_1 = 39.64 \text{ mm}$; $L_T = 36.48 \text{ mm}$; $L_p = 41.52 \text{ mm}$; and $\theta = 86.36^\circ$.

[0244] Monolithically isled master cell interconnections in PV modules. The isled master cells disclosed herein may be connected in electrical series, parallel, or hybrid parallel-series arrangements in PV modules. These interconnections may be performed using Monolithic Module embodiments described earlier (for example when a plurality of icells are attached to a continuous backplane layer and all the icell to icell electrical interconnections are performed using the patterned M2 layer). Master cell interconnection design choice in the module (series, hybrid parallel – series, or even parallel) may be based on the master cell maximum-power-point (MPP) current and voltage (I_{mp} and V_{mp}), the number of master cells in the module, as well as the desired MPP current and voltage of the module. Often, standard crystalline Si modules are made of 60 cells arranged in 6 columns, with 10 cells in each column (6x10) although other module configurations including $6 \times 12 = 72$ cells may be used based on the requirements for module power, module format, safety, BOS (e.g., wiring) cost, etc.

[0245] One exemplary module configuration embodiment for master cell interconnects (assuming N is at least 3) in a module of 6x10 (or more) master cells is a hybrid parallel-series configuration. Depending on the specific application and market, master cell interconnections may be optimized using a hybrid parallel-series design to provide the desired maximum module MPP current or the desired maximum module MPP current. And while an all-parallel configuration is possible, in some instances an all-parallel configuration may result in an excessively large module current resulting in significant ohmic losses. Further, while an all-series configuration is possible, in some instances an all-series configuration may result in an excessively high (for example larger than several hundred volts) module voltage (module V_{mp}) which may cause safety concerns and/or may demand higher wiring costs due to the dielectric insulation requirements.

[0246] Figs. 23A and 23B are diagrams showing a master cell or icell overview highlighting the position of the emitter and base busbars as dependent on the number of isles (odd or even number of isles), as well as M2 interconnection design. Both master

cell **452** in **Fig. 23A** and master cell **462** in **Fig 23B** have an array of $S = N \times N$ isles (or $N \times N$ subgroups of parallel-connected isles) – individual isles not shown. In master cell **452** N is an odd integer and in master cell **462** N is an even integer. As can be seen in **Fig. 23A**, master cell **452**, when N is an odd integer and the isles (or subgroup of parallel-connected isles) are connected in electrical series, the master cell emitter and base busbars are positioned opposite the cell diagonal in two opposite quadrants – shown as emitter busbar **454** and base busbar **456** in **Fig. 23A** (for example see the master cells shown in **Figs. 15A** and **15B**). In master cell **462** N is an even integer and the isles (or subgroup of parallel-connected isles) are connected in electrical series, the master cell emitter and base busbars are positioned on the two opposite corners on the same side of the square cell - shown as emitter busbar **464** and base busbar **466** in **Fig. 23B** (for example see the master cells shown in **Fig. 14A**).

[0247] **Figs. 24** through **27** are diagrams depicting various 60 cell module connection designs for master cells designs having both an even and odd number of series connected isles (or subgroups of parallel-connected isles), such as those shown in of **Figs. 23A** (N is odd) and **23B** (N is even). The diagrams of **Figs. 24** through **27** are top module views (showing the frontside of the master cell) showing emitter busbars and base busbars for each master cell although the busbars are actually positioned on the backsides of the master cells. In other words, the emitter and base busbars and module interconnections are shown as visible through the master cell frontside to emphasize various cell-to-cell interconnection designs. Each of these representative modules may be made as a monolithic module by attaching or laminating a plurality of icells (e.g., 60 icells in a 6 x 10 arrangement as shown in these embodiments) to a continuous backplane sheet after completion of the solar cell backside processing through the patterned M1 layer and then performing the remaining post-backplane-lamination back-end solar cell processing on the continuous multi-cell backplane substrate through completion of the patterned M2 layer on the large continuous backplane sheet comprising the plurality of icells. This approach will result in interconnections of the icells to one another according to a desired electrical interconnection arrangement (all series or hybrid parallel-series) using the monolithic patterned M2 metallization layer. This results in a monolithic module, eliminating the need for tabbing and/or stringing and/or soldering of the solar cells to

each other for module assembly (since patterned M2 already completes the cell-to-cell interconnections based on the monolithic module embodiment). Of course, each of these representative modules may also be made without the monolithic module embodiments disclosed herein by conventional tabbing and/or stringing and/or soldering of the solar cells to each other for module assembly.

[0248] Fig. 24 is an example of a module interconnection design (which is made using the patterned M2 layer if using monolithic module embodiments disclosed herein) for master cells or icells with emitter and base busbars positioned on opposite diagonal corners of the master cell (i.e., N is an odd number) and all icells connected in electrical series (all-series). Module voltage and current for 60 master cells connected in electrical series as shown in **Fig. 24** may be calculated as follows: module voltage = 60 x master cell voltage. Thus, for N = 4 and S = 16: master cell voltage $V_{mp} \approx 16 \times 0.59 \approx 9.4$ V; module $V_{mp} = 60 \times 9.4 = 564$ V; and module $I_{mp} \approx 9.3$ A/16 ≈ 0.58 A.

[0249] Fig. 25 is an example of a module interconnection design (which is made using the patterned M2 layer if using monolithic module embodiments disclosed herein) for master cells with emitter and base busbars positioned on corners on the same side of the master cell (N is an even number) and all cells connected in electrical series (all-series). For N = 4 and S = 16, module voltage and current may be calculated as described for **Fig. 24**.

[0250] Fig. 26 is an example of a module interconnection design (which is made using the patterned M2 layer if using monolithic module embodiments disclosed herein) for master cells with emitter and base busbars positioned on corners on the same side of the master cell (N is an even number) and the cells connected in electrical hybrid parallel-series. In this embodiment each master cell in a row of 10 master cells is connected in series and the 6 rows of 10 master cells are connected in parallel. In the hybrid parallel-series module interconnection embodiment shown in **Fig. 26**: module voltage = 10 x master cell voltage. Thus, for N = 4 and S = 16: master cell voltage $V_{mp} \approx 16 \times 0.59 \approx 9.4$ V and module voltage $V_{mp} = 10 \times 9.4 = 94$ V.

[0251] Fig. 27 is an alternative example of a module interconnection design (which is made using the patterned M2 layer if using monolithic module embodiments disclosed herein) for master cells with emitter and base busbars positioned on corners on the same

side of the master cell (N is even number) and the cells connected in electrical hybrid parallel-series. In this embodiment each master cell in a column of 6 master cells is connected in series and the 10 columns of 6 master cells are connected in parallel. In the hybrid parallel-series module interconnection embodiment shown in **Fig. 27**: module voltage = 6 x master cell voltage. Thus, for $N = 4$ and $S = 16$: master cell voltage $V_{mp} \approx 16 \times 0.59 \approx 9.4$ V; module voltage $V_{mp} = 6 \times 9.4 = 56.4$ V; and module current $I_{mp} \approx (9.3 \text{ A}/16) \times 10 \approx 5.81$ A.

[0252] In some instances, the monolithically isled architecture disclosed herein may integrate an embedded module-level or a cell-level DC-to-DC (or DC-to-AC) power optimizer which may be mounted directly on the master cell backplane prior to final module lamination or embedded within the module laminate. The MPPT Power optimizer may be a high-conversion-efficiency (for example greater than 97% efficiency) monolithic or hybrid chip (possibly including some discrete components comprising at least an inductor and a capacitor) which converts cell DC output to either DC or AC output at a specified voltage or constant current (range). For example, a cell-level MPPT power optimizer chip may be used to produce AC cells while performing maximum-power-point tracking (MPPT), by converting master cell DC voltage and current (V_{mp} and I_{mp}) to AC voltage and current.

[0253] And if the master cells in a module are connected in all-series, the cell-level embedded MPPT may be set to produce a pre-specified fixed output current in each master cell under all illumination conditions while performing the MPPT power optimization function. This may ensure that all the master cells connected in series are current-matched. Similarly, if the master cells in the module are connected in a hybrid parallel-series arrangement, the cell-level embedded MPPT may be set to produce a pre-specified fixed output current in each master cell to provide a pre-specified parallel-string voltage under all illumination conditions while performing the MPPT power optimization function (and providing a pre-specified string voltage). This may ensure that all master cells or icells connected in series in each series string are current-matched while the parallel strings are also voltage matched.

[0254] **Figs. 28A** and **28B** are diagrams showing some representative examples of module interconnections embodiments for a 600 VDC PV system. **Fig. 28A** shows

example of module interconnections for a 1x16S (all-series) module design (60-cell modules) where $V_{oc}=657.6$ V and $V_{mp}=552.0$ V and **Fig. 28B** shows module interconnection embodiments for a 2x8HPS (hybrid parallel-series) design (60-cell modules) where $V_{oc}=657.6$ V and $V_{mp}=552.0$ V. **Figs. 29A** and **29B** are schematic diagrams showing module interconnections for a 1000 VDC PV system. **Fig. 29A** shows module interconnections for a 1x16S (all-series) design (60-cell modules) where $V_{oc}=657.6$ V and $V_{mp}=552.0$ V and **Fig. 28B** shows module interconnections for a 2x8HPS (hybrid parallel-series) design (60-cell modules) where $V_{oc}=986.4$ V and $V_{mp}=828.0$ V. Thus, V_{os} and V_{mp} are increased in 2x8HPS design for a 1000 VDV PV system as compared to a 2x8HPS design for a 600 VDV PV system or a 1x16S design for 600 or 1000 VDV PV systems.

[0255] Thus, in some specific embodiments, a 2x8 Hybrid Parallel-Series (2x8HPS) interconnection design may be chosen for the following advantages:

- Enable the use of pseudo-square crystalline silicon wafers to fabricate icells while maintaining important advantages of an all-series master cell (for example such as master cell flexibility due to straight bidirectional trench isolation scribe lines and an M2 metal layer with a thickness less than approximately 5 μ m if applicable);
- Current match/balance in pseudo-square crystalline silicon wafers, for example achieved by using $L_1 = 3.964$ cm, $L_2 = 3.836$ cm as shown (for 156 mm x 156 mm wafers);
- Also compatible with full-square master cell substrates, for example with $L_1=L_2=3.9$ cm as shown;
- Providing efficient PV system arrangement for both 600 VDC and 1,000 VDC systems (as well as other system voltages) with reduced BOS cost and higher system efficiency. In some instances, a 1000 VDC PV system may have higher system-level efficiency and lower BOS costs as compared to a 600 VDC system. (It has been noted, due to higher efficiency and lower BOS cost, a higher string voltage (1,000 VDC vs. 600 VDC) may provide an economic value of approximately \$0.10/W for an installed PV system). If desired, the module voltages can be set (e.g., lowered compared to an all-series module arrangement)

by interconnections of the icells within the module according to a hybrid parallel-series configuration.

- Integration of low-cost distributed shade-management (similar to a 1x16S design);
- Integration of low-cost remote module ON/OFF (similar to a 1x16S design);
- Integration of low-cost distributed cell-level MPPT (similar to a 1x16S design); and
- May be considered more tolerant of master cell isle parametrics variations as compared to a 1x16S design.

[0256] The benefits of the innovative aspects disclosed herein include but are not limited to: (i) reduced solar cell manufacturing (fab) process equipment and facilities capital expenditures (CAPEX); (ii) substantially reduced hazardous waste byproducts in the solar cell fab; (iii) reduced solar cell microcracks and/or breakage (for instance, due to elimination of the need for copper plating and its associated handling, sealing, and contacting requirements) and enhanced overall manufacturing yield; (iv) improved projected long-term PV module field reliability; (v) reduced bow and mechanical stress for backplane-laminated solar cells due to elimination of the need for thick (typically 10's of microns for IBC solar cells) electroplated copper on the backside.

[0257] In operation, the disclosed subject matter provides monolithically isled master cells (icells) which may provide any combination of the following advantages: enhanced flexibility and crack mitigation; reduced cell bow and improved planarity; scaled-up voltage and scaled-down current, resulting in reduced RI^2 ohmic losses; a reduction in cell metallization thickness (as much as 10x) may allow for the elimination of copper plating if desired which may reduce cell metallization cost (for example $\leq 5 \mu\text{m Al}$); the elimination of thick metallization, such as thick-copper, reduces stress effects (and resulting cracks) during module lamination; distributed cell parametrics at test and sort; reduced current allows for an inexpensive shade-management switch; allows for the use of an inexpensive, high-efficiency (>98%) MPPT DC-DC buck converter; and a fully plating-free solar cell.

[0258] The present application relates to cost-effective, high-efficiency solar cells and related modules, their device structure and methods for manufacture. More specifically,

the disclosed subject matter relates to solar cell structures and manufacturing methods using wire-sawn, standard thickness (e.g., 125 mm x 125 mm or 156 mm x 156 mm or larger-area silicon wafers with starting thicknesses in the range of about 120 to about 250 microns) starting crystalline silicon wafers which may be thinned in conjunction with a supporting backplane (such as a flexible polymeric backplane which is permanently attached to the thin silicon cell absorber). The semiconductor absorber layer may be segmented using a monolithic fabrication process to provide multiples of the standard operating voltage of standard monolithic silicon cells while scaling down the solar cell current for a given solar cell power as described above.

[0259] The disclosed subject matter addresses limitations of known methods relating to the use of bulk wafers and thin-film solar cell fabrication challenges and provides the combination of low-cost and high efficiency inter-digitated back contact (IBC) solar cells made using starting crystalline silicon wafers.

[0260] Medium grade minority carrier lifetime n-type wafers may be chosen, for example with starting minority carrier lifetimes on the order of about ≥ 100 μ s or more and manufactured using Czochralski (CZ) ingot growth, continuous or quasi-continuous CZ growth, or other methods which address the inherent n-type doping concentration gradient across n-type silicon ingots. Alternatively quasi-monocrystalline cast n-type silicon ingots or even multicrystalline silicon material may be chosen dependent on material quality and other process integration requirements. It is to be noted that some of the subsequent processes, such as texturing, require suitable adjustment depending on the starting material choice, for instance alkaline texture for monocrystalline compared to acidic texture for multicrystalline material (although both acidic and alkaline textures may be used for any type of starting crystalline silicon material).

[0261] It is also to be noted that while n-type (typically phosphorus doped) starting crystalline wafers are provided for descriptive purposes, the fundamental concepts presented herein adhere to and may be applied by one skilled in the art to p-type silicon wafers. It is further to be noted that the fundamental concepts presented apply to bulk wire-sawn wafer-based absorber cells but may also be transferred to absorber cells generated using kerfless techniques such as those using porous silicon on a reusable template as a release layer system followed by epitaxial or otherwise chemical vapor

deposited film growth with subsequent release with subsequent reuse of the template. The structures and methods disclosed herein are also applicable to other so-called kerfless wafer methods such as those using high-dose hydrogen ion (proton) implantation and subsequent exfoliation or laser splitting or mechanical stress induced exfoliation of thin silicon substrates from thicker reusable starting substrates.

[0262] Various solar cell processing steps may be applied to the wafers, particularly back side processing steps, including the patterned formation of base contact and emitter diffusions (the formation of emitter and base contact regions) and the application of a patterned thin first metal layer (M1). Such base contact and emitter diffusions, be it in a selective or non-selective emitter structure, may be formed, for instance, using laser ablation of doped dielectrics and subsequent drive-in. These patterned regions, formed by local removal of doped dielectric layers, may also be generated by the application of etching paste by means of printing such as screen printing. Alternatively, patterned regions of different dopant level or polarity may also be created by the local application of dopant pastes, with subsequent thermal drive-in steps. Combinations of such above patterning methods are also readily deducible.

[0263] Subsequently, a low cost backplane (such as a low-cost prepreg or polymeric material) having an expansion coefficient (CTE) relatively matched to the solar cell absorber material (for example crystalline silicon) is laminated to the backside of the processed wafer. The crystalline silicon wafer may then be thinned (for example using either a chemical wet etch or alternatively using a dry etch process) to the desired absorber thickness range providing an optimal balance between value-add optical absorption and minority carrier lifetime. Providing a thin silicon (e.g. 20 μm to 90 μm thick) absorber and handling and processing capabilities for such thin silicon absorber cells through an automated or partially automated solar cell production line at high mechanical yield is key to achieving low-cost, high efficiency solar cells and makes the structures and processes disclosed herein very attractive for low-cost, high-volume production.

[0264] Further, the silicon substrate attached to a backplane may be segmented by forming trench isolation regions, for example using pulsed laser cuts to electrically

isolate individual silicon islands or segments (isles, sub-cells, or mini-cells) as described in detail above, thus enabling monolithic solar cell fabrication.

[0265] Fig. 30 illustrates such a cell structure. Fig. 30 is a diagram of solar cell 500 having a 4 x 4 array of sub-cells 502 I₁₁ through I₄₄ defined and electrically isolated by trenches 504 and which is reinforced by contiguous monolithic backplane sheet 506 (for example an electrically insulating, low-cost, flexible material such as a prepreg sheet or any suitable polymeric sheet). The isles are physically segmented and therefore electrically segmentable sub-cell active absorber units which may be referred to as isles or sub-cells - in other words the group of monolithically integrated sub-cells isles form the main/master cell having a common backplane used for all the sub-cells.

[0266] After further processing steps such as wet chemical texturing etch (e.g., alkaline texture) and front side passivation layer deposition (for example using PECVD), access or via holes are drilled (for example using laser drilling) through the backplane to access the embedded cell terminals. Using a patterned second layer metal structure (M2) on the backside of the backplane, the segmented sub-cells may be electrically interconnected in parallel, in series or in a combination thereof, depending on various considerations including the desired master cell (also referred to as icell) current and voltage values. Thus, the monolithic master cell itself, held together by the backplane to e.g. a 156 mm x 156 mm square or pseudo-square form factor can provide operating voltages that are scaled-up a multiple of the standard voltage range a traditional silicon solar cell may generate, for instance N-times 0.6-0.7 V.

[0267] At the same time, the current output of same cell is divided by the same factor N (with N being an integer). With this high voltage and low current design the requirements for the total metal thickness of the solar cell are reduced drastically due to the much decreased ohmic I²R loss and further savings in metallization costs can be realized. Further as a result, the challenging introduction of metal (e.g., copper) plating for solar cell metallization is not necessary.

[0268] In addition, these scaled-up voltage scaled-down current solar cells also allow for improved economical novel solutions for module power harvesting and energy yield optimization. This is owed in part to the fact that the individual cell operating current and

voltage may be selected to be in the same ranges as the cost optimized current and voltage values for low cost commercial individual switches.

[0269] Further savings may also be realized within the module metallization as the individual module output current may be reduced and module output voltage may be increased thus reducing the thickness and electrical sheet conductance requirements for final cell metallization accordingly.

[0270] It is to be noted that throughout this disclosure the manufacturing methods and resulting structures, wherever they are not explicitly linked to the use of bulk crystalline silicon wafers that may be thinned to a suitable thickness (after backplane lamination), may also be extended to structures that are manufactured by deposition and subsequent release from reusable templates (or alternatively by exfoliation of thin silicon layers from reusable thicker wafers after treatment of the reusable wafer by a suitable technique such as laser splitting or MeV-scale hydrogen ion implantation or thick metal plating for stress-induced exfoliation). In the epitaxial deposition process, the active silicon absorber layer, rather than being generated from a starting bulk wafer, may be generated from a layer of in-situ-doped (typically doped with phosphorus for n-type silicon) crystalline silicon which is deposited using a chemical vapor deposition (CVD) process such as epitaxy on a reusable mono- or multi- or quasi-mono- crystalline template with a sacrificial layer or layer structure of, for instance, porous silicon, which is then subsequently partially processed on one side, for example to form patterned base contacts and emitter junction structures and a patterned first metal layer (such as by screen printing of a suitable metal paste such as aluminum-containing paste, or by PVD and laser ablation patterning), which is then subsequently laminated to a backplane, exfoliated by a release process and then finished off with the same isle segmenting (trench isolation) cuts, frontside texturing, passivation, backside via drill and a patterned second layer metal.

[0271] To better understand the advantages of thin silicon from a device point-of-view, particularly for back-contact/back-junction solar cells, consider the following.

[0272] A substantial advantage of thin absorber layers are the higher solar cell open-circuit voltage or V_{oc} limits when reducing the cell thickness. Thinner absorber layers are enabled by the presented cell structures and process flows described herein. **Fig. 31** is a

graph showing that the attainable V_{oc} limit increases with reduced cell thickness. (published by M. Green of UNSW “Limits on the Open-Circuit Voltage and Efficiency of Silicon Solar Cells Imposed by Intrinsic Auger Processes.”). Auger recombination imposes limits on V_{oc} and efficiency of Si solar cells. The open-circuit voltage or V_{oc} limit increases from about 750 mV for $W_{Si} = 300 \mu m$ to about 800 mV for $W_{Si}=20 \mu m$. The V_{oc} limits for larger L_{eff}/W_{Si} ratios are larger, therefore, thinner silicon absorber ultimately enables a higher efficiency (and a lower temperature coefficient of power or efficiency).

[0273] Looking at ultimate performance limits for silicon based absorbers it is necessary to look at bulk minority carrier lifetime, Surface Recombination Velocity (SRV), and effective minority carrier lifetime. Bulk recombination lifetime has several contributors. $1/t_b = 1/t_{radiative} + 1/t_{Auger} + 1/t_{defects}$. Silicon lifetime is dominated by defects (SRH) and band-to-band Auger recombination. In Auger recombination, the minority carrier (hole for n-type silicon) recombines with an electron, transmitting its energy to a 3rd charge (an electron in the CB or a hole in the VB), or lattice phonons. Auger recombination is dominant at a background doping concentration of around $N_d > 1 \times 10^{17} cm^{-3}$ in high-quality crystalline Si the effective lifetime (t_{eff}) depends on bulk lifetime t_b , effective surface recombination velocity S_{eff} , and the silicon absorber thickness (W_{Si}). For small S_{eff} ($S_{eff} < D_h/4W$ where D_h is the diffusivity of holes in Si): $1/t_{eff} \gg 1/t_b + 2S_{eff}/W_{Si}$, which is highly desirable with thin Si solar cells.

[0274] For large S_{eff} : $1/t_{eff} \gg 1/t_b + (\pi/W_{Si})^2 D_h$. This is highly undesirable, since: $t_{eff} \gg 0.14 \mu s$ for $W_{Si}=40 \mu m$, which may be too low to enable fabrication of high-efficiency solar cells. Therefore, for thin-silicon-absorber IBC solar cells, it is very important to achieve high-quality surface passivation with very low S_{eff} .

[0275] In some cases, high-efficiency, thin-silicon IBC solar cell design rules may require the effective minority carrier diffusion length $L_{eff} = \sqrt{D_h \cdot t_{eff}}$ to be a relatively large multiple of the silicon absorber thickness W_{Si} for achieving highest V_{oc} (≥ 700 mV) and J_{sc} (≥ 40 mA/cm²) values. In order to achieve both high open-circuit voltage and short-circuit current density, $L_{eff} \geq 15 \cdot W_{Si}$. Therefore, for an approximately 40 μm thick Si absorber, an $L_{eff} \geq 600 \mu m$ is desirable; for a hole diffusivity of $D_h \gg 12$ cm²/s, this condition amounts to a requirement of effective minority carrier lifetime $t_{eff} \geq 300 \mu s$.

[0276] Further, high-efficiency thin Si absorber solar cells often demand the highest-quality surface passivation (particularly the front-surface passivation for IBC cells): $S_{\text{eff}} \leq 5 \text{ cm/s}$ for front-surface passivation in thin-silicon IBC solar cells.

[0277] **Fig. 32** is a graph illustrating the silicon absorber effective minority carrier lifetime requirement (x-axis) versus final cell absorber thickness requirements (y-axis) for high-efficiency solar cells, showing the requirements for high performance of V_{oc} and J_{sc} . It can be seen that the high V_{oc} requirement places more stringent demand on the maximum allowable silicon thickness and/or minimum required minority carrier lifetime (as compared to the high J_{sc} requirement).

[0278] The post-etch and texture processes thin silicon thickness depicted show the thickness and lifetime requirements based on certain J_{sc} and V_{oc} design rules (for example, the effective minority carrier diffusion length in the absorber being at least $\sim 6\times$ the absorber thickness to meet the high J_{sc} requirement and $\sim 15\times$ the absorber thickness to meet the high V_{oc} requirement).

[0279] The starting material for the thin-semiconductor-absorber solar cell structures may be pseudo-square or full-square, n-type monocrystalline (also called quasi-mono or cast mono) silicon or n-type CZ silicon wafers (for instance produced by wire saw from CZ-grown mono-crystalline ingots or cast crystalline bricks) or depending on the material quality also multicrystalline silicon or upgraded metallurgical grade silicon. When CZ silicon is used growing methods that enable a tighter distribution of dopant concentration and resistivity, such as using a continuous CZ (CCZ) or quasi-continuous CZ growth of silicon ingots, may be selected.

[0280] Wafer size may be at least 156 mm x 156 mm or larger and the starting average wafer thickness may be in the range of approximately 80 μm to 250 μm . Thinner and/or lower cost wafers may be utilized as long as manufacturing yield is not compromised by reduced mechanical yield due to enhanced wafer breakage during and after cell processing. And wafer bulk minority carrier lifetime may be at least 100 μs and in some instances several hundreds of μs - carrier lifetimes obtainable using inexpensive n-type CZ wafers.

[0281] The solar cell fabrication process may be started by single-sided in-line or batch immersion Saw Damage Removal (SDR), which is a wet etch process, optionally

followed by a chemical polishing step to smooth out surface asperities. Such polishing steps may be performed single sided or double sided, for instance using chilled or room temperature mixtures containing hydrofluoric acid (HF) and nitric acid (HNO₃) or alternatively using alkaline etch processes such as hot potassium hydroxide at concentrations above 15%, etches may be followed up by a metal removal etch such as with HCl, HF or HCl / HF combinations and then completed with an HF containing clean to remove the native oxide and to leave the surface hydrophobic and hydrogen terminated.

[0282] Depending on the choice of starting wafer source, it may be advantageous to manufacture at this early stage in the process flow a back surface field or back surface doping layer which lowers the overall sheet resistance of the base which is otherwise typically governed by the wafer resistivity and its thickness. However, as standard CZ growth of n-type ingots is typically accompanied with a large gradient of dopant due to dopant segregation and thus a large variation in wafer resistivity across an ingot (from seed end to tail end), it may be advantageous to have a tighter range of base sheet resistance by utilizing additional doping on the back surface of the wafer. Provided herein are several different embodiments for achieving such an increased doping area. It is to be noted that newer ingot fabrication methods, such as continuous or quasi-continuous CZ growth, are currently addressing and reducing the aforementioned ingot doping gradient, and therefore alleviating or obsoleting the need for said additional doping within the solar cell base region.

[0283] Subsequently, a large part of the solar cell backside processing may be performed, namely the patterned formation of emitter and base contact diffusions, for example using a combination of dielectric deposition steps such as doped glass depositions using atmospheric pressure chemical vapor deposition (APCVD) and/or plasma-enhanced chemical-vapor deposition (PECVD), subsequent damage-free or low-damage laser patterning, for example using pulsed nanosecond, picosecond or femtosecond laser ablation patterning and thermal (e.g., batch tube or in-line furnace) drive-in for emitter junction (and doped base and emitter contact diffusion regions, as required) formation – in other words, generally the formation of emitter and base contact regions.

[0284] Laser beams for such processes may be homogenized to a spatial top hat profile for best uniformity or be Gaussian or have intermediate intensity distribution shapes. Backside dielectric depositions may consist of doped or undoped silicon-oxide glasses such as boron-silicate glass (BSG), phosphorus-silicate glass (PSG) or undoped-silicate glass (USG) or of other dielectrics such as aluminum oxide or silicon nitride, doped or undoped, or a combination thereof.

[0285] Further, a patterned first metal layer may be applied to the backside of the cell, for example a metal consisting of an aluminum or aluminum containing alloy (such as a screen-printable paste or inkjet-printing ink comprising aluminum-silicon) paste. The first metal layer may be annealed particularly if it consists of a screen, ink jet or otherwise printed paste. Alternatively, physical vapor deposition (PVD) such as DC magnetron plasma sputtering and/or evaporation of one or more metallic materials (such as aluminum or aluminum-silicon alloy) may be applied to form the first metal level, followed by patterning of the PVD layer, for instance through the use of pulsed picoseconds or nanoseconds laser ablation of PVD metal on top of the dielectric glass, where required. This forms the contact metallization layer on the solar cell. The emitter and base structure as well as the patterned first-level relatively thin metal layer (for instance with a sheet resistance in the range of about 0.01 Ω /square to 0.5 Ω /square), may be formed and patterned as a busbar-less interdigitated back contact (IBC) base and emitter metallization (Metal-1 or M1 metal layer) scheme. M1 geometry should be to provide for the possibility for subsequent segmentation and thereby physical and electrical separation of the underlying silicon into isles after the subsequent backplane lamination or attachment.

[0286] For backplane lamination or attachment, a flexible thin backplane (such as a suitable prepreg or polymeric material in the thickness range of about 50 μm to 200 μm) may be laminated to the IBC M1 metal side. The backplane sheet may be substantially the same size and shape as the wafer (or slightly larger if desired for cell edge protection). The backplane serves several important functions including as a permanent support to provide high yield thin silicon cell manufacturing and support the segmentation of the silicon wafer/ into a plurality of physically and electrically

segmented cells on one cohesive backplane. The solar cell design referred to herein as 'iCell' or 'island cells' including embedded electronics.

[0287] The backplane supported silicon wafer may then be thinned down to an optimal thickness (for example in the range of approximately 80 μm to as thin as a few microns depending on the specific application for the resulting solar cell) using a wet (such as with hot KOH or TMAH or with mixtures containing HF and HNO_3) or dry (plasma or reactive ion etch RIE) silicon etching process. Alternatively, abrasive processes such as grinding or lapping or chemical-mechanical polishing (CMP) may be used to reduce the silicon thickness. Other methods such as laser splitting or MeV-range hydrogen ion implantation followed by thin silicon cleavage / exfoliation may be used and the separated substrate may be reused to make additional solar cells depending on the starting wafer thickness.

[0288] The iCell (isled solar cell) structure may then be formed through pulsed ns or ps (or fs) laser ablation, ultrasonic drilling, or mechanical sawing of the silicon wafer to form silicon isolation trenches and create sub-cells or isles (all supported by the common backplane). Cutting or scribing processes may be tuned such that the trench goes all the way through silicon to the backplane, or that the trench ends with a thin layer of silicon still remaining which is then removed during a subsequent final wet etch and/or wet texturing process (which may also remove sidewall damage caused by the cutting process).

[0289] Subsequently, remaining cell process steps may be carried out including, for example, the aforementioned sunnyside texture (for improved light trapping), followed by post-texture cleaning.

[0290] The following description and corresponding process flows teach several embodiments for fabricating an optional front surface field at this point in cell manufacture process, all of which use processes that are essentially "low temperature" in the sense that they are compatible with a backplane that can only withstand extended thermal processing at temperatures up to around the 300°C range.

[0291] Then front side passivation and anti-reflective coating (ARC) layer deposition may performed (for example by PECVD followed by drilling vias into the backplane to access the buried M1 layer) followed by the backside final patterned solar cell

metallization (second level metallization: Metal-2 or M2) process for isle/subcell interconnection. M2 deposition may be performed as a patterning process (for instance, PVD with *in-situ* shadow masking) or as a blanket process with subsequent patterning (for instance, using blanket PVD of aluminum with a suitable capping layer such as an optional nickel or nickel-vanadium, which may further comprise an optional top cap of tin (Sn) or other solderable surface material, and a subsequent pulsed laser ablation to pattern the M2 metal).

[0292] And while the examples and descriptions provided herein utilize crystalline silicon, other crystalline semiconductor materials may be utilized as well, such as gallium arsenide (GaAs) or combinations, for instance of silicon with GaAs, optionally with a germanium (Ge) or silicon-germanium ($\text{Si}_{1-x}\text{Ge}_x$) buffer layer between the Si and the GaAs. Further, while the examples provided are back contact cells, the inventive concepts disclosed herein may be extended and readily adopted to other cell designs, such as non-IBC back-contact cells, or front contact cells, and may be especially applicable as a technological simplification choice when integrating GaAs into the Si process.

[0293] While alternative variations and embodiments of solar cell structures in accordance with the disclosed subject matter, exemplary embodiments are provided in the cross-sectional diagrams of **Figs. 5D** and **5E**.

[0294] The structure of **Figs. 5D** and **5E** is an interdigitated back-contact/back-junction crystalline semiconductor solar cell comprising a thin (for example having a thickness sub-100 μm in the range of a few microns up to approximately 100 microns) crystalline silicon layer formed by optionally etching back a thicker CZ or monocrystalline (quasi-mono) silicon layer using wet or dry etching or by abrasive thickness reduction such as grinding or lapping (or alternatively using a starting thin sub-130 μm wafer, without a need for dedicated silicon thinning etch back process).

[0295] It is to be noted that thinning/etching back the silicon after backplane lamination (other than any silicon thickness reduction as a result of the texturing process) may not be required in some instances if a wafer with suitably high lifetime and/or sufficiently reduced starting thickness is used. Such a structure optionally allows for completing the front surface processing, including texture and passivation to a point prior to lamination. This has the potential advantage that high temperature processes to form a doped front-

surface field (FSF) layer (using phosphorus diffusion or phosphorus ion implantation and thermal anneal activation, or another technique) and to passivate the front surface, with relatively high thermal budgets which are not compatible with a flexible polymer containing backplane, may be carried out prior to the lamination. For instance, a diffused front surface field (from diffused Phosphosilicate glass: PSG, POCl_3 or implanted phosphorus as precursors) may then be employed. The use of the backplane enables the physical segmentation of the cells into isles/sub-cells for icell fabrication and with it the high voltage – low current solar cell architecture which in turn removes the need for a thick metallization scheme and the need for thick metal (such as copper/nickel/tin) plating process and associated technological risks, such as contamination of the active silicon with copper. Elimination of plating also reduces the overall solar cell manufacturing cost and capex. Backside passivation may include a material stack such as a phosphosilicate glass on a borosilicate glass.

[0296] The sunny side of the thin-silicon solar cell comprises a light-trapping texture (formed by wet etch texturing and/or dry laser or plasma texturing) and a subsequent PECVD process to form the passivation and anti-reflection coating (ARC) layer(s).

[0297] The back-contact/back-junction solar cell of **Figs. 5D** and **5E** comprises semiconductor absorber layer having a first level metal (M1) made using a suitable (low-cost and high electrical conductivity) metal layer such as aluminum or aluminum-silicon alloy forming an interdigitated back-contact (IBC) emitter and base metal finger pattern, for example a busbar-less IBC finger pattern (fine pattern pitch). Lack of busbars on M1 may eliminate efficiency losses due to busbar-induced electrical shading. Based on the two-level metallization scheme here, M1 serves as the contact metallization layer (with fine-pitch interdigitated base and emitter metal fingers) while M2 provides the higher sheet conductivity interconnect layer to extract the solar cell power with minimal ohmic losses.

[0298] The backside of the thin-silicon solar cell is a thin backplane sheet, for example between 50 and 200 μm thick, and may be a flexible polymeric laminated sheet containing fibers, such as a prepreg sheet. The backplane sheet is relatively thermal-expansion-matched (or CTE matched) to silicon in terms of the respective coefficients of thermal expansion (CTE) to mitigate cell breakage during thermal processing.

[0299] The interdigitated back-contact/back-junction solar cell comprises a patterned second level metal (M2) which may have a thickness in the range of approximately 1 to 55 μm , in some instances having a coarser pitch (and hence less fingers) as compared to M1 and a substantially orthogonal pattern with respect to M1. Patterned M2 is electrically connected to patterned M1 through pre-specified M1-M2 conductive via plugs formed in the backplane. M2 may be any conductive material or material stack including materials such as aluminum, copper, or aluminum with Al/Zn or NiV.

[0300] Fig. 5E provides a high level cross-sectional diagram representation of the final solar cell structure for the back contact / back junction thin silicon solar cell, comprising a thin semiconductor (e.g. sub-100 μm crystalline silicon) cell absorber which is formed by etching back a thicker starting silicon wafer, a passivation and anti-reflection coating (ARC) on a textured surface on the sunny side, for example a stack comprised of amorphous silicon (a-Si) and silicon nitride or one of aluminum oxide and silicon nitride; a backplane, for example a laminated flexible polymeric sheet such as prepreg, an interdigitated M1 pattern, for instance, busbarless thin aluminum metal fingers on the cell backside; a patterned orthogonal second level metal, shown here for M2 using patterned metal comprising aluminum and / or copper, where the M2 PVD metal is less than about 10 microns in thickness and in some instances having a thickness in the range of between about 1 and 5 μm thick.

[0301] Each of the sub-cells or isles in the monolithic icell may include a set of mini bus bars of at least one per polarity through which the connections to adjacent sub-cells are made, in parallel or in series. The emitter and base diffusion regions as well as the IBC metallization pattern may be arranged in an advanced geometry to minimize electrical shading underneath the mini bus bars.

[0302] Various process flow options are provided herein to illustrate the capabilities of various aspects of the disclosed processes and structures.

[0303] A starting material of n-type crystalline silicon may be selected from monocrystalline silicon (Czochralski or CZ), monocrystalline silicon (monocast (also called cast-mono or quasi-mono or seeded cast mono), or cast multicrystalline silicon. The starting wafer size may be a full-square (or full rectangle), pseudo-square (or pseudo rectangle) or other geometrical shapes (e.g., hexagonal, other polygonal shaped, etc.) with areas at least 150

cm² and in some instances at least 240 cm². The starting wafer thickness may be less than approximately 250 μm and optionally having the thinnest thickness allowing for the combination of lowest starting wafer cost and high fab yield to enable negligible breakage.

[0304] On the patterned and diffused interdigitated backside region, which is covered with a suitable low surface recombination enabling dielectric which includes patterned contact openings to the underlying silicon, a first metal (M1) solar cell contact metallization may be formed directly on the silicon contact regions, where the metal extent may be larger than the silicon contact opening. This first metal (M1) layer may be formed for example, using one of the following methods: screen printing of a paste, inkjet printing of an ink, aerosol jet printing of an ink, or physical-vapor deposition (plasma sputtering, thermal evaporation, electron-beam evaporation, ion beam deposition, or thermal/arc spray deposition). PVD of M1 may require a patterning step such as selective laser ablation of metal after deposition unless the PVD process deposits a patterned M1 layer such as by using an *in-situ* shadow mask.

[0305] The backplane may be a sheet or plate, for example a flexible thin polymeric or composite epoxy resin with fiber content (such as prepreg) sheet laminated to the cell backside after completion of patterned M1. The backplane may also be applied by screen printing, spray coating, or alternative deposition method.

[0306] A silicon etch back (wafer thinning) may be performed for example by wet etch or dry etch (plasma or RIE) or alternatively using a suitable grinding or lapping process. This wafer thinning may be economically carried out using hot concentrated KOH (or NaOH) for example with concentrations of KOH above 15% (and as high as 45%) and with temperatures of 90°C or higher (in some instances, depending on the process controllability, as high as 150°C).

[0307] A second metal layer (M2) on the backplane may be formed for example by a PVD method (e.g., plasma sputtering and/or thermal evaporation, e-beam evaporation, thermal spray, or arc spray) and pulsed laser ablation patterning (for instance using pulsed nanoseconds laser ablation), or by screen printing of a high-conductivity paste comprising aluminum and/or copper or by PVD through an *in-situ* shadow mask. The latter is feasible as the pattern size and alignment requirements for M2 are substantially

coarser than those for M1 (in some instances due to the substantially orthogonal alignment of M2 with respect to M1).

[0308] The thin silicon n-type base parasitic resistance may be reduced by either an optional doped front-surface field (FSF) formed by laser doping of phosphorus (or arsenic, antimony, or indium) or by laser activation of implanted phosphorus, arsenic, or antimony on the textured surface, or by formation of a blanket phosphorus buried layer adjacent to the emitter by either phosphorus (e.g., POCl_3) diffusion or phosphorus ion implantation with a subsequent shared anneal.

[0309] The following paragraphs provide various embodiments of process flows including a general approach as well as examples of individual flow embodiments.

[0310] For clarity the process flows provided may be divided into seven building blocks, and each building block may contain more than one process tool and more than one unit fabrication process. **Fig. 33** is a process flow diagram illustrating high-level solar cell building blocks.

[0311] As shown in **Fig. 33**, the first building block includes starting wafer inspection, selection, and preparation. The second block includes back surface engineering, with and without the addition of a doped back surface field (BSF) during this process sequence. The third block is first level metal (M1) formation (also known as contact metallization). The fourth block is lamination of the backplane to attach the permanent reinforcement backplane. The fifth block includes wafer segmentation into sub-cell units or isles for the formation of the overall monolithic icell architecture, the etch-back, texturing and post texture cleaning. The sixth block includes front-surface engineering, including the front-surface passivation, with and without the addition of an internal front-surface field (FSF). The seventh block consists of generating access to the buried back side as well as the second-level metal (M2) formation and an optional final anneal (which may be done *in situ* during the M2 PVD process).

[0312] Each of these building blocks may contain a variety of process flow embodiments, various examples of which will be described. Different process route options or embodiments within each building block may be combined with different process route options or embodiments of other building blocks. As there are a multitude of combinations possible, the disclosed subject matter includes the broadest scope of all

such combinations, even when the given examples do not cover all possible process flow combinations.

[0313] Expanding **Block 1** in **Fig. 33**: the starting wafers may first receive an optional inspection followed by an optional pre-clean, followed by saw damage removal (SDR), for instance, using an alkaline chemistry such as hot KOH or NaOH, or acidic chemistry such as HF/HNO₃. Following this the wafers may optionally receive a chemical polishing etch, either single or double sided, for instance, using highly concentrated mixtures of HF and HNO₃, in some instances chilled. This polishing etch is followed by a short KOH etch to remove etching stains such as porous silicon from the surface. Afterwards, wafers receive a metal removal clean, for instance, using HCl or mixtures of HCl with HF, or ozonated HF, optionally followed by a final HF dip to render the surface hydrophobic and remove the native silicon dioxide (and to make the crystalline silicon surface hydrogen terminated as a result of dilute HF dip treatment).

[0314] Next, expanding on **Block 2** of **Fig. 33**, back surface engineering with and without the addition of a back surface field (BSF) or improved back surface base electrical sheet conductivity enhancement (to reduce the parasitic base resistance and its detrimental impact on the solar cell fill factor). This aggregate block of processes consists of several process steps. It may start with an optional back surface electrical conduction enhancement designed to overcome a large resistivity spread or variations among starting wafers across ingots and among ingots. Such resistivity spreads may result in excess base resistance and therefore non-optimal (reduced) solar cell fill factor, or in the case of a high doping to insufficient minority carrier lifetime of those starting wafers which are on the lower scale of the bulk resistivity (or higher background doping concentrations). However, there are ingot growth methods available that provide tight enough resistivity specifications and spread to not require back surface conduction enhancement, such as continuous CZ ingot growth techniques. Example flows utilizing ingots and wafers with a tight resistivity specification are depicted in **Figs. 34A** through **34D**. In cases where a back surface conduction enhancement is desired, several representative embodiments are presented. The first embodiment is shown in the example flows in **Figs. 35A** through **35D** and provides the introduction of an n-type dopant such as phosphorus by means of POCl₃ thermal furnace doping, in conjunction with a thermal drive-in step, and by a

subsequent wet etch (HF dip) removal of the remaining phosphorus doped glass (phosphor-silicate glass or PSG) from the surface. A second embodiment is shown in the example flows in **Figs. 36A** through **36D** and provides an ion implantation step of n-type dopant species such as phosphorus (P), arsenic (As), antimony (Sb), or indium (In). This implant (such as phosphorus implant) is then thermally annealed as part of a later furnace anneal step described below and which serves several purposes.

[0315] Following saw damage removal step (process **Block 1**) or for alternative embodiments following the back surface electrical sheet conduction enhancement steps, an atmospheric pressure chemical vapor deposition (known as APCVD), or alternatively PECVD, of a first layer of boron-doped glass (such as BSG) is performed. The BSG layer may have a comparatively low boron concentration to enable the formation of a selectively lighter-doped emitter with a comparatively higher sheet resistance across the cell, and is subsequently patterned, for example using a pulsed picoseconds (ps) or femtoseconds (fs) laser or alternative laser capable of ablating the BSG dielectric at minimal to no damage to the underlying silicon. Wherever the BSG is removed during ablation, a higher boron-doped emitter (to be utilized for low-resistance emitter contact regions) will be formed in further processing. Subsequently a second layer of BSG, which may have a comparatively higher concentration of boron, is deposited by APCVD (or alternatively PECVD) and which may serve as a precursor for the selective emitter contact.

[0316] Subsequently, an additional patterning step using a pulsed picoseconds or femtoseconds laser may be employed removing BSG in regions where the n⁺ doped base contact regions should be formed. A layer of phosphosilicate glass (PSG) may then be deposited (by either APCVD or PECVD) which serves as the precursor for the phosphorus doped base contact regions (with n⁺ doping for low base contact resistance).

[0317] The evolving solar cell structure then undergoes a high temperature furnace anneal which drives in the patterned p-type and n-type diffused regions into the structure backside. This anneal may be performed in an inert and/or oxidizing ambient or a stepwise mixture of inert and oxidizing ambient and at temperatures above 800°C, more specifically between 850 and 1100°C. Additional steps such as gettering, for instance in temperature ranges around 550°C to 650°C, or even forming gas anneals, typically

carried out in temperature range of 400°C to 500°C deg C (e.g. at 450°C) may also be integrated into the above annealing step. In cases where the back surface had previously received an implanted dopant, as mentioned above, for instance, using phosphorus and arsenic, then this thermal anneal step also serves to anneal, activate and diffuse the implant region.

[0318] It is, however, also possible and may be advantageous to push and pull the furnace at a relatively high temperature so that faster heat-up and cool-down rates can be established which serves to arrest oxygen precipitation from the wafer material and may also improve furnace process throughput. Example pushing and pulling temperatures are chosen such that the boats are pushed and pulled at temperatures above 600°C, and in some instances at or above 800°C to 850°C. Such high temperature pushing and pulling of the furnace boats may be implemented instead of or in conjunction with the lower temperature gettering and FGA depicted in most flow embodiment examples.

[0319] Subsequent to the furnace anneal a laser, for example a pulsed picoseconds or femtoseconds laser is employed to open the contacts to the respective emitter and base contact regions for subsequent M1 contact metallization process. Optionally, an additional anneal, for instance in an inert non-oxidizing ambient, may then be performed to reduce potential damage from the laser contact opening step.

[0320] It is to be noted that above described ablation processes to locally remove dielectric such as doped glasses using a laser to generate the desired pattern may also be achieved by means of using a suitable etchant paste. For a unit process of such etchant paste, the etching paste is applied locally, for instance using screen printing. Depending on the nature of the etchant paste (for instance containing or not containing hydrofluoric acid) the etching mechanism may require a thermal activation (for such pastes not based on hydrofluoric acid). This activation may be achieved, for instance, in a belt or roller furnace and is part of the etch dimension and depth control. Subsequent to etching, the etching paste may be removed by means of a cleaning and rinsing step, for instance using light alkaline solutions, followed by DI water rinsing and optional metal removal steps such as a short HCl containing wet clean.

[0321] Interdigitated back contact structure with local diffusions of different concentration and opposite polarity may also be formed using dopant paste, applied for

instance using screen printing, with subsequent thermal drive-in. This replaces the deposition and subsequent patterning of dielectric dopant precursors such as doped glasses. Combinations of the above processes are also readily derivable.

[0322] **Block 3** of **Fig. 33** includes the first level metallization (M1 or solar cell contact metallization) formation. For M1, two distinctly different path examples or process embodiments are provided. First, the application of patterned first level metal M1 in the form of screen, stencil, inkjet or otherwise printing a paste or ink, in one printing step or optionally in more than one coat, with optional drying steps in between, followed by a main curing process, which in turn may consist of several curing steps in one curing tool such as a tube furnace or an in-line furnace, to first drive out or burn off binder from a paste, followed by a resistivity reduction sintering step. Suitable pastes may be made of aluminum, aluminum alloyed with silicon and/or germanium, as well as nickel, silver, or other conductive materials. Process examples printing the M1 layer are depicted in **Figs. 34A** through **36D** and **Figs. 38A** through **41B**. Alternatively, the first level metal may be deposited in a blanket mode, for instance using PVD (such as DC magnetron plasma sputtering), of for example aluminum, aluminum alloyed with silicon and/or germanium, as well as nickel (Ni) or nickel-vanadium (NiV). After the PVD deposition, the blanket metal layer is patterned, for instance using a pulsed nanoseconds, picoseconds, or femtoseconds laser to ablate metal between the terminals or anywhere else where it is not desired. Illustration of an example of such a process flow is depicted in **Fig. 42**. Combinations of printing and PVD are also feasible, as well as the addition of conductive dots such as paste or ink dots in regions where additional thickness and/or an alternate metal is desired.

[0323] Further, there are embodiments to the second and third process blocks provided below. For example: the selective emitter design (comprising less heavily doped main field emitter and more heavily doped emitter contact regions) previously presented utilizes a dual layer BSG deposition and a pulsed picoseconds or femtoseconds laser patterning step may also utilize a single BSG layer to generate the lightly doped emitter region and a selective pulsed nanoseconds laser drive-in and alloying step for the highly doped part of the emitter (using p++ doping from subsequent M1 aluminum layer) which serves directly as an emitter contact. For such a process the first BSG patterning and the

second BSG deposition processes are omitted. Instead, the first level metal (in this case aluminum or an alloy of aluminum with silicon and/or germanium) is driven in (serving as p-type heavy emitter contact doping) subsequent to deposition by using a pulsed nanosecond laser which melts the surface of M1 layer, for instance Al and creating a eutectic Al-Si melt, and alloys it with the underlying silicon. The deposited M1, for instance Al, may be deposited and patterned using PVD with a subsequent laser ablation for patterning or may be formed using a screen printing or inkjet printing (or another printing) process using a frit-less aluminum-containing paste. In the case of the PVD with subsequent laser ablation pulsed laser ablation may be used for patterning in the same tool or same step as the laser emitter contact alloying - in other words using two different laser processes in the same tool.

[0324] Alternatively to laser based contact opening of the emitter and base regions for the subsequent M1 metallization at the end of the second processing block, a suitable M1 paste with a frit or other etching component may be used, which, upon thermal processing, locally etches through the dielectric and makes contact to emitter and base regions without the need of a laser based contact area dielectric ablation. The M1 paste containing frit may also be split into a dual print paste with different pastes for the different polarity regions (emitter and base) and which may be thermally annealed at the same time or in two different steps, depending on the optimum annealing conditions for high quality ohmic contact while retaining reasonably low contact recombination for both polarities.

[0325] After the back surface engineering and first level metal (M1 or contact metallization) formation described above, the wafer is ready for the fourth process block, **Block 4 in Fig. 33**, laminating a backplane, for example a flexible backplane, onto the structured wafer backside. While the backplane may be made of a variety of materials, it may be advantageous that the backplane adheres to several requirements depending on the solar cell fabrication method and resulting cell use: 1) the backplane may have a close thermal expansion coefficient match to the underlying patterned silicon stack; 2) the backplane may have flexibility; 3) the backplane may be chemically resistant to subsequent wet and dry processing steps such as silicon etching and texturing (unless all wet processing is performed prior to the lamination process), and; 4) the backplane

should withstand the thermal budgets of the subsequent passivation dielectric anneal and second level metal deposition processes and allow for sufficiently high temperature processing (e.g., up to approximately 300 or even 400 °C).

[0326] The lamination process may be a vacuum lamination process to avoid formation of bubbles at the interface between the backplane sheet and the silicon layer with the structured M1-metallized backside. Sufficient pressure should be exerted (between 10 and 400 psi or in some instances more specifically between 50 and 250 psi) during the lamination to enable the flow of resin from the prepreg backplane laminate which in turn planarizes the laminated cell structure. The size of the prepreg may be chosen to closely match that of the cell to be laminated while slight over- or undersizing may bear advantages for subsequent processing. The backplane sheet may have a thickness in the range of about 50 microns to 250 microns. After the lamination, an optional edge trim may be performed, for example using a pulsed nanosecond laser.

[0327] The fifth process block **Block 5** in **Fig. 33**, pertains to the optional segmentation of the wafer into sub-cells (isles) to form an icell (or isled master cell), silicon thinning for example using wet or dry chemical etching or abrasive methods, and texturing and post texture cleaning. After the lamination is complete, the wafer backside structure is laminated to the backplane and the backplane itself protects the buried backside structures from subsequent processes. Subsequently, the wafer may be: 1) thinned – to enable the use of lower lifetime wafers for making highly efficient back-contact solar cells with thinned absorbers; 2) the absorber material segmented into electrically isolated (via trench isolation) monolithically-integrated individual sub-cells (isles) which are later electrically interconnected in series or in parallel or in a combination of parallel and series; 3) textured on the front surface, for example to form random pyramidal structures on the front surface, followed by cleaning of the textured surface prior to the PECVD passivation process.

[0328] Various different embodiments are possible to achieve the above result of a thinned, segmented, textured array of individual cells on the backplane. The cross-sectional diagrams of **Figs. 37A** and **37B** illustrate different process sequences as well as the structures during and at the end of the sequences. **Fig. 37A** illustrates cross-sectional diagrams showing a process comprising a wafer thinning step prior to wafer segmentation

(for example using laser trench formation) and **Fig. 37B** illustrates cross-sectional diagrams showing a process comprising partial wafer segmentation (for example using laser trench formation) prior to wafer thinning and following wafer thinning and texturing.

[0329] In one embodiment the segments/isles are first formed with a pulsed laser isolation trench either fully through the complete absorber layer or partially through the absorber layer (for instance a trench depth suitable such that a subsequent absorber layer removal/thinning by etching and texturing etches far enough to effectively and reproducibly form the trench-isolated sub-cells/isles. In yet another embodiment, the absorber layer (e.g. the silicon wafer) is first thinned to its final thickness (plus the silicon that is to be textured later), then segmented either fully through the remaining thinned absorber layer or almost completely such that the subsequent texturing process is sufficient to separate the individual sub-cells or isles. A third embodiment utilizes a combination between the two above sequences where in a first step most of the thinning etch is performed, followed by complete or almost complete trench-isolated segmentation, followed by further etching and sunnyside texturing.

[0330] In a fourth embodiment, the isolation cut is performed after thinning and texturing are both completed. This embodiment may include two additional options. In one option, after the segmentation cut the wafer surface goes directly into passivation. This has the advantage of reducing the overall number of wet process steps. Another option is perform a slight cleanup step to remove debris and potential damage from the laser step. Such cleanup steps may consist of a short immersion in an alkaline chemistry such as the texture chemistry itself, followed by suitable post texture clean, or by mild debris removals such as megasonic cleans.

[0331] It is important to note that the trench isolation segmentation process itself should leave the backplane material relatively intact to retain structural integrity of the cell such that the cell sandwich may be processed using a typical cell form factor, such as 156 mm x 156 mm square or pseudo square with the respective automated equipment that can handle such standard sizes.

[0332] In the case of a prepreg backplane and a silicon absorber it may be advantageous to cut the absorber with a laser source using a laser wavelength with good absorption in

silicon while having with poor absorption in prepreg (i.e., being transmitted and/or reflected by the prepreg with little absorption) – a concept which holds for other backplane/absorber material combinations as well. Many prepregs do not absorb strongly in the infrared (IR) wavelength so cutting with IR enhances the relative selectivity of silicon cutting versus prepreg cutting. Cutting or scribing using IR lasers is also comparatively cheap, as capex (capital expenditure) and maintenance for IR lasers (e.g. pulsed nanosecond lasers) are typically lower as compared to UV lasers.

However, cutting quality for UV lasers tends to be better than for IR lasers and the extent of the heat affected damage zone near the cut is smaller for UV lasers. In each case these factors should be weighed in order to make the optimal laser source selection for the trench isolation process.

[0333] In addition, isolation trenches may be formed using water jet guided lasers, such as water jet guided green or IR lasers. Water jet guided laser cuts may exhibit cutting regions with lower damage while retaining the absorption and therefore selectivity advantage of the lower wavelength laser or lasers. Other segmentation methods to generate a monolithic backplane-attached icell solar structure include buried focused laser beams for splitting where the focus may be placed within the material and temperature gradient and with it internal vapor pressure induced material splitting is the result. Such induced splitting may be assisted by splitting from a laser source which is closely traced and followed by a cooling source such as a water or dry ice jet. Dicing methods, such as diamond wheel saw cutting, may also be employed for the segmentation, but tend to be more expensive. When employed, such dicing cuts the silicon just inside the prepreg to form the separation.

[0334] The silicon wafer thinning itself may be performed using a high etch rate wet etch solution, such as for instance concentrated KOH or other hydroxides such as NaOH, TMAH, NH₄OH or LiOH, using relatively high temperatures of 80°C and above (in some instances up to approximately 145°C). Alternative wet chemistries such as mixtures containing at least HF and HNO₃ with optional additive such as acetic, phosphoric or sulfuric acid may be used but are typically more expensive. This acidic etching is performed at room temperature or below and in solutions that allow for chilling to remove heat generated from the exothermic etching reaction.

[0335] In order to fully utilize the etching chemistry, particularly but not solely for the case of alkaline etching, flocculating agents may be introduced during the process to help flocculate out the reaction product of potassium silicate (in the case of a silicon etch) and a KOH etchant or hexafluorosilicic acid (in the case of an HF / HNO₃ based etchant chemistry) and which then support a mechanical separation of reaction product, for instance either by sedimenting bed or centrifugal demixing. An alternative method for removing byproduct out of solution is by thermally cycling the solution (i.e. cooling it down to reduce the solubility and removing the components that fall out of solution, such as silicate, and reheating). By separating the silicate, byproduct may be separated from the etchant and thus the bath lifetime of the etchant extended as the balance of the spent etchant such as KOH or NaOH may be spiked back into the bath, either from solid bricks or flakes of KOH (or other hydroxides) or from highly concentrated aqueous solution.

[0336] Yet another option for silicon thinning by etching is the use of plasmas, such as halogen containing plasmas for silicon etching. Also, a high etch rate molecule radical etch is envisioned. Other options for silicon wafer thinning include mechanical grinding or lapping down the silicon. In some instances, grinded silicon is potentially more readily separable for recovery and recycling.

[0337] After the sunnyside (frontside) texturing, a surface cleaning process such as those containing HCl, HF or HNO₃ or ozonated HF followed by a final dilute HF etch treatment is carried out and an optional final HF containing step may leave the surface without a native oxide.

[0338] It is to be noted that when performing a segmentation cut prior to silicon thinning (for example by laser), the presented process flows depict a cut of approximately 30-70% of the thickness with the subsequent etch extending the depth of the cut to the prepreg boundary to complete the isolation. The initial segmentation cut may also be a complete cut (and not to rely on the etching to provide the full segmentation isolation) as shown in the process flow of **Fig. 43**.

[0339] **Block 6 of Fig. 33** includes solar cell front surface engineering including front surface passivation application with or without an additional doped front surface field (FSF). For implementation of doped front surface fields a variety of embodiments are provided which all have a dopant source, for n-type absorber cells typically containing

phosphorus, arsenic or antimony or indium dopant and a drive-in and/or dopant activation mechanism, such as pulsed nanoseconds laser annealing or pulsed nanoseconds laser doping. The dopant sources may be provided by various methods, including ion implantation, predeposition of material layers containing dopants, predeposition of sprays containing dopants, plasma immersion ion implantation – for instance using PH₃, or gas immersion laser doping (GILD). Process flow embodiments that implement doped front surface fields (FSF) are outlined in **Figs. 38A-38D, 39A-39D, 40A-40D, and 41A-41B**. In such methods it may be advantageous to have an effectively low temperature drive-in mechanism, such as a pulsed nanoseconds laser annealing or melting, or melting in a dopant ambient (GILD), so that the heat is concentrated to the front of the solar cell and the backplane does not receive excessive heat and remains relatively unheated and unaffected by the frontside pulsed laser processing. For laser sources, pulses sources, such as pulsed nanoseconds lasers, may be used for formation of doped FSF. In order to overcome topographical challenges such as the random pyramid textured surface, anneal may be performed using a pulsed nanoseconds (with pulse length in the range of about 10 ns up to 100's of ns) green laser that can distribute the heat into the top few microns of absorber, or a pulsed UV laser which, from a heat dissipation point of view, will deliver most of the heat in the pyramid tips. Top hat or flat-top homogenized laser beams may also be used.

[0340] Various options for front surface passivation layers there are also various options, from silicon nitride to stacks of amorphous silicon (a-Si) with silicon nitride, or specifically intrinsic a-Si, followed by n-doped a-Si, followed by silicon nitride. Instead of silicon nitride, oxide nitride or oxynitrides with fixed or variable oxygen content may also be used. Instead of a-Si, the initial layer may also contain some fraction of oxygen to become an amorphous silicon-oxide (also possible with sub-stoichiometric content of oxygen), or amorphous silicon-carbon with a relatively small portion of carbon. Another alternative to a-Si is aluminum oxide (Al₂O₃) which is capable to produce very low surface recombination velocity on both p- and n-type silicon (for example Al₂O₃ deposition using methods such as ALD, PECVD, or APCVD) and which is also readily combined with silicon nitride, where silicon nitride is deposited after as a second layer. When silicon nitride is used, the stoichiometric ratio between nitrogen and silicon may be

fixed or variable throughout the film to enable optimized optical and electrical performance, where optimized optical performance is achieved at low or zero absorption in the film and the correct effective film thickness and refractive index and best electrical performance may be achieved with sufficient hydrogen content and relatively large fixed positive charge density (in the case of n-based cells).

[0341] The seventh building block **Block 7** of **Fig. 33** involves the formation of access holes (vias) to make contact to the buried metal 1 (M1) layer and the deposition and structuring of metal 2 (M2). Metal 2 (M2) forms the final high-conductivity solar cell metallization, isle to isle interconnection, with the cell busbars.

[0342] Forming via holes to interconnect M2 and M1 at this stage in cell fabrication has an inherent advantage that during the preceding wet process steps, such as etch-back, texturing and post texture cleaning, the buried M1 layer has been protected by the laminated backplane. Via holes may be drilled using lasers such as pulsed CO₂ lasers, or pulsed UV lasers. In some instances, vias may be positioned on an optionally widened M1 layer finger in order to have more forgiving alignment tolerances. Alignment of the vias to underlying interdigitated M1 fingers, as well as alignment of the trench isolation segmentation cuts to the structures on the backside of the absorber wafer, may utilize infrared illumination of alignment marks which have sufficient transmission through the silicon absorber layer as well as through the backplane.

[0343] After formation of the via holes in the backplane with via holes landing on the designated portions of M1 interdigitated fingers, the structure is ready for the M2 deposition and patterning, which may be preceded by a pre-deposition in-situ sputter etch clean (for instance using argon, oxygen or other plasmas or ions) to etch off poorly conductive surface layers such as aluminum oxide or carbon residue on top of the M1 contact and to promote M2 adhesion on the backplane surface.

[0344] Such a process may be performed in a vacuum PVD system comprising vacuum-integrated plasma sputtering and evaporation process capabilities. Subsequently, and preferably without breaking vacuum, the M2 layer can be deposited. The M2 layer may be depositing using, for example, PVD such as aluminum evaporation (by thermal or electron-beam evaporation of aluminum) or plasma sputtering, optionally followed by at least one capping layer that serves as adhesion, anti-oxidant and contacting layer, such as

a thin (having a thickness in the range of approximately 100 nm to 500 nm) nickel or nickel-vanadium layer and an optional tin (Sn) or other solderable material coat.

[0345] Subsequent to or as a result of the inherent heating during PVD deposition of M2, the cell may be annealed to further improve surface passivation properties with reduced surface recombination velocities and reduce cell metallization contact and via resistances. M2 may then be subsequently patterned, for instance using pulsed laser ablation, to separate emitter from base contact regions while establishing (and leaving intact) the suitable pre-designed interconnections (serial, parallel or combinations) between the individual isles or sub-cells. The patterned M2 may also comprise the final solar cell busbars. Alternatively to PVD (plasma sputtering and/or evaporation) of M2, other deposition techniques such as screen or ink jet printing, or thermal spray coating, or arc plasma spray coating, or plating may be employed.

[0346] The following detailed process flows for the manufacture of back contact solar cells are provided as exemplary embodiments highlighting various key aspects of the disclosed subject matter. Various aspects of each flow may be removed or combined and the flows provided should not be construed in a limiting sense. Note that while these process flows are directed towards isled master cells (icells) they may also be applied to the formation of back contact solar cells not utilizing a monolithically isled solar cell structure. And while certain distinctive elements of each process flow are highlight, all follow the general building blocks provided in **Fig. 33** and share number of common elements, including:

- Saw Damage Removal (SDR), Tool 1, which also reduces the silicon wafer thickness and its overall surface roughness on both sides of the wafer. SDR may be either double-sided or single-sided etch tool (batch or in-line design).
- A patterned screen-printed M1 paste (for example using a suitable high-conductivity fritless paste comprising aluminum). Patterned M2 formed by PVD (plasma sputtering, and/or evaporation, and/or another suitable PVD method such as arc or thermal spray) followed by pulsed laser ablation patterning of the deposited metal layer; while M2 is shown with PVD AL/NiV, other material options are possible, including: Al/Ni, Al/Zn, Cu/Ni, Cu/Zn, etc. If desired, PVD copper may be used as the main M2 conductor instead of aluminum.

- Partitioning laser scribe to form the trench isolation regions for the monolithic solar cell isles of the icell (may also be referred to as “iCell” cut/scribe/trench in the process flows). With reference to **Fig. 34A**, this laser partitioning scribe (Tool 12) may be removed from the flow and Tools 11 and 13 combined into a single wet processing equipment (i.e., 15 process tools without isle partitioning as compared to 17 process tools with isle partitioning in the flow of **Fig. 34A**) - a process removal step which holds true in all process flows.
- A silicon etch back is performed to reduce the absorber thickness to a range of approximately 50 to 80 microns (Tool 11 in **Fig. 34A**, note this tool number reference varies in different process flow embodiments) and subsequently another 5 to 15 micron thickness reduction during the texture etch process (Tool 13 in **Fig. 34A**, note this tool number reference varies in different process flow embodiments) for a final silicon absorber thickness in the range of approximately 35 to 75 microns although thinner or thicker absorber Si may be formed.
- Trench isolation regions may be formed (may also be referred to as “iCell” scribe/cut/trench in the process flows) before the Si etch back (wafer thinning), between the Si etch back and cell sunnyside (frontside) texture, or alternatively at any point after backplane lamination depending on process flow constraints and desired cell structure.
- Process flows may start with quasi-mono or CZ n-type Si wafers.
- Isolation trenches are formed using pulsed ns laser scribing after Si etch back (wafer thinning).
- Al paste and furnace anneal processing are used to form patterned M1.

[0347] **Figs. 34A** through **34D** are process flow embodiments for the manufacture of interdigitated back contact solar cells with no FSF or BSF formation for base conductivity – in other words no additional n⁺ doping in the n-type base for reducing the base resistance is used. **Flows 34A** and **34B** describe flows without and with *In-Situ* Masking of PVD for M2 and the isle laser cut (“iCell Pulse ns Laser Scribe”) is performed between Si thinning Etch Back and sunnyside Texture/Post-Texture Clean. **Flow 34A** shows PVD M2 without *in-situ* PVD masking of M2 and using laser ablation patterning. **Flow 34B** shows PVD M2 with *in-situ* PVD shadow masking for patterned

M2. **Flows 34C and 34D** describe flows without and with *In-Situ* shadow Masking of PVD for M2 and the isle laser cut is performed before Si Etch Back (Reduces Tool Count by One). **Flow 34C** shows PVD M2 without *in-situ* PVD shadow masking of M2 and using pulsed laser ablation patterning. **Flow 34D** shows PVD M2 with *in-situ* PVD shadow masking for patterned M2

[0348] **Figs. 35A through 35D** are process flow embodiments for the manufacture of interdigitated back contact solar cells with a buried BSF for base conductivity – in other words additional n+ doping in the n-type base for reducing the base resistance, process shown using POCl₃ doping after SDR followed by POCl₃ glass etch + Si etch. **Flows 35A and 35B** describe flows without and with *In-Situ* shadow Masking of PVD for M2 and the isle laser cut is performed between Si Etch Back and Texture/Post-Texture Clean. **Flow 35A** shows PVD M2 without *in-situ* PVD shadow masking of M2 and using pulsed laser ablation patterning. **Flow 35B** shows PVD M2 with *in-situ* PVD shadow masking for patterned M2. **Flows 35C and 35D** describe flows without and with *In-Situ* shadow Masking of PVD for M2 and the isle laser cut performed before Si Etch Back (Reduces Tool Count by One). **Flow 35C** shows PVD M2 without *in-situ* PVD shadow masking of M2 and using pulsed laser ablation patterning. **Flow 35D** shows PVD M2 with *in-situ* PVD masking for patterned M2.

[0349] **Figs. 36A through 36D** are process flow embodiments for the manufacture of interdigitated back contact solar cells with a buried BSF for base conductivity - in other words additional n+ doping in the n-type base for reducing the base resistance, process shown using phosphorus ion implantation and subsequent shared furnace anneal (ion implant places the peak of P below the subsequent emitter-base junction). **Flows 36A and 36B** describe flows without and with *In-Situ* Masking of PVD for M2 and the isle laser cut between Si Etch Back and Texture/Post-Texture Clean. **Flow 36A** shows PVD M2 without *in-situ* PVD shadow masking of M2 and using pulsed laser ablation patterning. **Flow 36B** shows PVD M2 with *in-situ* PVD shadow masking for patterned M2. **Flows 36C and 36D** describe flows without and With *In-Situ* Masking of PVD for M2 and isle laser cut performed before Si Etch Back (Reduces Tool Count by One). **Flow 36C** shows PVD M2 without *in-situ* PVD shadow masking of M2 and using pulsed

laser ablation patterning. Flow **36D** shows PVD M2 with *in-situ* PVD shadow masking for patterned M2.

[0350] Figs. **38A** through **38D** are process flow embodiments for the manufacture of interdigitated back contact solar cells with laser-doped FSF for base conductivity – in other words additional n+ doping in the n-type base for reducing the base resistance, process shown using laser doping on front-side after Si etch back and texture/clean (pulsed ns laser doping is done after applying the phosphorus liquid source, post texture). Laser-doped FSF may serve two objectives: improved front-side passivation and reduced base resistance (for example doping depth ~0.1 to 0.5 microns, surface conc. ~1E17 to 5E19 cm⁻³, lower surface concentrations for deeper doping and vice versa).

[0351] Flows **38A** and **38B** describe flows without and with *In-Situ* Masking of PVD for M2 and isle laser cut between Si Etch Back and Texture/Post-Texture Clean. Flow **38A** shows PVD M2 without *in-situ* PVD shadow masking of M2 and using pulsed laser ablation patterning. Flow **38B** shows PVD M2 with *in-situ* PVD shadow masking for patterned M2. Flow **38C** is for PVD M2 without *in-situ* PVD shadow masking of M2 and using pulsed laser ablation patterning. Flow **38D** shows PVD M2 with *in-situ* PVD shadow masking for patterned M2.

[0352] Figs. **39A** through **39D** are process flow embodiments for the manufacture of interdigitated back contact solar cells with pulsed laser FSF for base conductivity – in other words additional n+ doping in the n-type base for reducing the base resistance, process shown using laser doping on front-side after Si etch back and texture/clean (pulsed ns or ps laser is applied after depositing a thin sub-250 nm layer of n+ phosphorus or arsenic doped amorphous Si, to perform epitaxial alignment of the doped amorphous Si to reduce base resistance, with surface conc. ~1E17 to 5E20 cm⁻³, lower surface concentrations used for thicker n+ amorphous Si and vice versa).

[0353] Flows **39A** and **39B** describe flows without and with *In-Situ* Masking of PVD for M2 and isle laser cut between Si Etch Back and Texture/Post-Texture Clean. Flow **39A** shows PVD M2 without *in-situ* PVD shadow masking of M2 and using pulsed laser ablation patterning. Flow **39B** shows PVD M2 with *in-situ* PVD shadow masking for patterned M2. Flows **39C** and **39D** describe flows without and with *In-Situ* Masking of PVD for M2 and isle laser cut before Si Etch Back (Reduces Tool Count by One). Flow

39C shows PVD M2 without *in-situ* PVD shadow masking of M2 and using pulsed laser ablation patterning. Flow **39D** shows PVD M2 with *in-situ* PVD shadow masking for patterned M2.

[0354] Figs. **40A** through **40D** are process flow embodiments for the manufacture of interdigitated back contact solar cells with ion implantation FSF for base conductivity – in other words additional n+ doping in the n-type base for reducing the base resistance, process shown using ion implantation of phosphorus or arsenic on the textured sunny side followed by laser annealing to activate implanted dopant after Si etch back and texture/clean (pulsed ns laser is applied after implanting a thin, for example sub-500 nm, implanted layer of n+ phosphorus or arsenic doped layer, to form an activated n+ layer to reduce base resistance, with surface conc. $\sim 1\text{E}17$ to $5\text{E}20\text{ cm}^{-3}$, lower surface concentrations used for thicker n+ amorphous Si and vice versa).

[0355] Flows **40A** and **40B** describe flows without and with *In-Situ* Masking of PVD for M2 and isle laser cut performed between Si Etch Back and Texture/Post-Texture Clean. Flow **40A** shows PVD M2 without *in-situ* PVD shadow masking of M2 and using pulsed laser ablation patterning. Flow **40B** shows PVD M2 with *in-situ* PVD shadow masking for patterned M2. Flows **40C** and **40D** describe flows without and with *In-Situ* Masking of PVD for M2 and isle laser cut performed before Si Etch Back (Reduces Tool Count by One). Flow **40C** shows PVD M2 without *in-situ* PVD shadow masking of M2 and using pulsed laser ablation patterning. Flow **40D** shows PVD M2 with *in-situ* PVD shadow masking for patterned M2.

[0356] Figs. **41A** through **41D** are process flow embodiments for the manufacture of interdigitated back contact solar cells with gas immersion FSF for base conductivity – in other words additional n+ doping in the n-type base for reducing the base resistance, process shown using laser gas immersion doping in PH_3 on front-side (FSF depth ~ 0.1 to $0.3\text{ }\mu\text{m}$) after Si etch back and texture/clean (pulsed ns laser is applied in PH_3/H_2 for gas-immersion laser doping to reduce base resistance, with surface conc. $\sim 1\text{E}18$ to $5\text{E}20\text{ cm}^{-3}$, lower surface conc. used for deeper doped region and vice versa).

[0357] Flows **41A** and **41B** describe flows without and with *In-Situ* Masking of PVD for M2 and isle laser cut performed between Si Etch Back and Texture/Post-Texture Clean. Flow **41A** shows PVD M2 without *in-situ* PVD shadow masking of M2 and using pulsed

laser ablation patterning. Flow **41B** shows PVD M2 with *in-situ* PVD shadow masking for patterned M2.

[0358] Figs. 42 is a process flow embodiment for the manufacture of interdigitated back contact solar cells with no FSF or BSF for base conductivity and pulsed ns laser scribing of isolation trenches using PV-Al/NiV and laser ablation patterning of M1.

[0359] Figs. 43 is a process flow embodiment for the manufacture of interdigitated back contact solar cells using pulsed ns laser scribing of isolation trenches on pre-etch thick silicon.

[0360] Different metallization options for first metal (M1) layer include, among others, screen printing or stencil printing or deposition using physical vapor deposition (PVD) such as a DC magnetron plasma sputtering process with a subsequent patterning step, for instance using pulsed laser ablation patterning. M1 material choices include, among others, screen printed aluminum (Al), aluminum with silicon and/or germanium content, aluminum and silver combinations (if different metals are to be used for emitter and base), as well as nickel, for instance deposited in a patterned or blanket way using ink jet printing. Material choices for M1 PVD also include Al, Al with Si and/or Ge, followed by Ni or NiV. The considerations outlined below should be weighed relating to material choices for M1.

[0361] Advantages of using PVD Al/NiV (with Al in the range of from a fraction of $\sim 1\ \mu\text{m}$ to $2\ \mu\text{m}$ and relatively thin NiV in the range of $\sim 0.1\ \mu\text{m}$ to $0.50\ \mu\text{m}$) and pulsed laser ablation patterning instead of screen-printed patterned Al paste and furnace anneal include the fact that PVD provides much lower near-bulk Al resistivity of $\sim 2.7\ \mu\Omega\cdot\text{cm}$, almost a factor of about 15x to 100x lower than the cured Al paste resistivity, hence, reducing the required Al layer thickness to about a fraction of $1\ \mu\text{m}$ up to about $2\ \mu\text{m}$ (compared to about $15\ \mu\text{m}$ to $30+\ \mu\text{m}$ for Al paste)

[0362] Compared to paste much thinner PVD Al reduces the M1 stress on thin silicon and compare to screen-printed Al paste much thinner PVD Al facilitates backplane lamination due to reduced surface topography on patterned M1 with the much thinner PVD Al layer. Eliminating the screen printing process from the process flow may lead to higher mechanical yield in the production line as screen printing can be a primary source of wafer breakage in the line (the only contact type tool in the flow). Eliminating screen

printing may also enable the use of thinner and less expensive starting wafers without serious breakage concerns. PVD Al is also much more pure than Al paste (e.g., much less impurities such as Fe) and thus potentially enables higher Voc and higher resulting cell efficiency. PVD Al may reduce the overall M1 resistance and provide lower M2-M1 via plug/contact resistance thus reducing the number of required via holes drilled into the backplane, resulting in higher productivity for the backplane laser drilling process.

[0363] Disadvantages of using PVD Al/NiV and pulsed laser ablation instead of screen printed Al include the possible risk of punching through the much thinner PVD Al M1 during backplane drilling. The necessary patterning step, for example in the case of laser ablation, also bears a risk of Al/NiV laser ablation damage and minority carrier lifetime degradation in the solar cell. Further, a PVD plus laser ablation toolset also carries a higher Capex cost compared to screen print with subsequent furnace cure.

[0364] In the process flows described previously, the screen printed aluminum layer for M1 may be replaced with PVD Al/NiV followed by pulsed laser ablation of Al/NiV. It is also possible to combine processes, such as using a lower PVD layer for good and low contamination contact formation, followed by a screen printed thickening layer to provide a thicker landing pad layer for the laser via hole drill process to stop on. This second layer process may also serve as a mask for a subsequent etching and patterning process to remove the thinner PVD layer where it is not desired – thus the laser ablation process and associated risk of damaging the back surface passivation may be avoided. In other words, the screen printed layer would serve as a mask for the PVD etching by choosing etches and metal combinations that allow for selective etching of the PVD layer at a higher rate than the screen printed layer. Alternatively the etching may be performed with a less selective chemistry and rely that the metal in the screen printed area is much thicker than the metal in the PVD only area. In the latter case, the etching needs to be timed suitably.

[0365] Additional known options for the M1 layer may be incorporated into the disclosed process flows. For instance, it is also possible to deposit a very thin layer that may be transferred into a silicide using a rather low temperature process. An example is nickel or cobalt and the formation of a nickel silicide or cobalt silicide. Other materials, such as titanium and other refractory metals are also possible; however, nickel may be

advantageous due to its low consumption of silicon and low silicidation reaction temperature. The nickel silicide is only formed in the contact areas which are previously opened (oxide is removed), for example using a pulsed picoseconds or femtoseconds laser ablation process in the contact areas. After nickel deposition (by PVD) and thermal anneal, nickel silicide is formed only in the open areas where nickel is in contact with silicon. Afterwards, remaining unreacted nickel may be stripped from the dielectric region, forming localized self-aligned contacts. As contact resistance values with silicides may be relatively low, such a process may be used to lower the overall contact area percentage and thereby reduce the overall back surface recombination velocity (BSRV), which can lead to higher open circuit voltages and higher resulting cell efficiencies. This silicidation may also be performed in conjunction with a local nickel deposition, for instance, using ink jet deposition of nickel dots which may be reacted, thereby removing the need of selectively wet etching unreacted nickel from other regions.

[0366] The presented process and resulting cell structure may utilize a flexible, CTE matched backplane to provide a cell design with increased flexibility, especially in conjunction with the thin or thinned absorber layer. The absorber layer may already be thin (below about 80 μm), for instance formed as a deposited epitaxial thin-film growth onto a reusable template with a kerfless process, or may require thinning, for example, after lamination for the case of a thicker (approximately 100 to 180 μm thick) starting CZ or otherwise crystalline wafer or when formed as a thicker deposited epitaxial growth onto a reusable template. Cell flexibility lends itself to flexible module encapsulation concepts, for example glass free modules providing a very thin, lightweight and flexible module. These same flexible module attributes may also further reduce installation and overall balance of system (BOS) costs for such manufactured modules.

[0367] Additional methods for the patterning of the backside structures (emitter and base junction regions as well as the contact region opening for the M1 to make contact to the emitter and base contact regions) are further provided. Generally, back surface recombination velocity is to be kept low for high performance IBC cells. Damage to the structured regions which may be caused by laser processing can be detrimental to the BSRV and with it to the attainable open circuit voltage performance. As the structuring of the back side relies on the selective removal of oxide by pulsed laser ablation, for

example doped glasses from certain regions using a laser, much care is to be taken to reduce and/or avoid damage from the laser process. Pulsed picoseconds and femtoseconds lasers may avoid such damage but may still leave some residual damage which can reduce the resulting cell efficiency.

[0368] As an alternative process, the use of masking layers and subsequent masking layers patterning using lasers is provided, for example with an oxide removal performed using a wet etching step such as using buffered or unbuffered hydrofluoric acid (HF). The cross-sectional diagrams of **Figs. 44A** and **44B** illustrate these concepts. **Fig. 44A** is a cross-sectional diagram showing direct oxide ablation using a ps laser of a BSG (or PSG) layer on a silicon layer. Laser ablated opening **520** is formed by laser beam distribution **526** in BSG (or PSG) layer **522** exposing Si layer **524**. Damaged Si regions may be formed in Si at glass to Si interfaces **528** and excess beam energy region **530**.

[0369] **Fig. 44B** is a cross-sectional diagram showing ablation of a hardmask using a ps or ns laser and wet etch opening of a BSG (or PSG) layer on a silicon layer. Laser ablated opening **548** is formed by laser beam distribution **546** in hard mask layer **540** on BSG (or PSG) layer **542** on silicon layer **544**. Hard mask layer **540** may be a temporary hard mask such as a resist or polymer or a permanent hard mask such as a-Si. A wet etch then forms wet etch opening **552** exposing damage free region **550** in silicon layer **544**. For example, the masking layer may be applied in the form of amorphous silicon on top of the deposited glass, in some instances in the same atmospheric pressure deposition tool, or alternatively using PECVD or PVD. The thin (in the range of approximately 50 to about several hundred Angstroms thick) amorphous Si (a-Si) is then selectively ablated with the laser and provides a hard mask for the subsequent etching step. The unablated a-Si in the untreated regions need not be removed, but merely oxidized as part of the subsequent furnace anneal step. This process may readily be implemented for the case of the selective emitter window and the base window opening processes.

[0370] As an alternative to the use of a-Si, the masking layer may for example also consist of a polymer such as resist or photoresist or other organic material. The thickness of the polymer may be less than a micron and the application method may have a very high polymer or resist utilization rate, such as roller coating or spray coating. A key

requirement of the polymer or resist is that it adheres well to the glass and may sustain the oxide etching process using buffered or unbuffered HF.

[0371] The subsequent laser step, in one embodiment, then ablates the resist or polymer, then the glass underneath is locally etched away, followed by stripping of the resist or polymer (in some instances in the same tool as the etch). This method buys a large process margin for laser processing as the polymer may be ablated at a much lower laser fluence than even the a-Si or the glass, thereby resulting in undamaged contact regions. This method also allows for the use of nanosecond lasers which are cheaper and cheaper to operate than picoseconds lasers. And this process may readily be implemented for the contact opening laser process step prior to M1 contacting, as the polymer or resist is removed after the glass etch.

[0372] At the penalty of a higher material cost the polymer or resist may also be photosensitive, for example with a positive photoresist action and the laser process only exposing the photoresist (rather than ablating it). In this case, the ensuing wet step first develops the resist in a batch or inline bath, followed by the local glass etching, followed by the resist removal and cleanup step (in some instances all performed in one wet tool).

[0373] **Figs. 45 through 49** show several representative process flow embodiments for the fabrication of a backplane-attached back contact solar cell wherein: (i) no post-lamination wet processing is performed, and (ii) the silicon wafer is not thinned beyond the thinning performed by the SDR and texture processes. These process flows result in back-contact solar cells with thicker absorber layers (typically in the range of about 100 μm up to about 150 μm) as compared to earlier process flows. In **Figs. 45 through 49**, the frontside passivation includes a thin thermal oxide underlayer in conjunction with a hydrogenated silicon nitride field-assisted passivation layer (also serving as anti-reflection coating or ARC layer). The passivation layer may, for example, be a stack of PECVD hydrogenated amorphous silicon and silicon nitride (without the thin thermal oxide).

[0374] In **Figs. 45 through 49** are bulk CZ wafer back contact solar cell process flows with no selective emitter and utilizing a Top-Hat pulsed laser ablation with no laser damage removal process. **Fig. 45** is a process flow utilizing two APCVDs and three furnaces. **Figs. 46 through 48** are process flows utilizing two APCVDs and two furnaces. **Fig. 49** is a process flow utilizing one APCVDs and two furnaces.

[0375] While these process flows are shown without selective emitter formation, they may be extended to include selective emitter (for example by addition of one APCVD BSG and one pulsed laser ablation process steps). Key advantages of these process flow embodiments include:

- No post-lamination wet chemical processing eliminates the risk of chemical attack on the backplane or delamination of the backplane.
- Doped front surface field (FSF) may be formed conformal to the frontside texture using standard phosphorus doping furnace without any constraints associated with the backplane material and without a need for pulsed laser doping for FSF.
- The five flows depicted in **Figs. 45** through **49** result in back-contact cells with thicker absorber layers (as compared to thinned silicon absorber process flows), thus they require starting wafers with relatively higher minority carrier recombination lifetimes in order to achieve same high efficiencies as the thinned silicon solar cells produced by the process flows provided above.

[0376] As noted previously, in some instances it may be desirable to remove base and emitter doping agents after formation of solar cell back side base and emitter regions and subsequently deposit a backside passivation layer. In certain solar cell fabrication process flows, such as those described herein, removing doping agents and residue (for example by etching and referred to as etch back or strip etch) post base and emitter formation (e.g., post dopant diffusion) allows for deposition of a backside passivation layer post high temperature anneal dopant processing which may mitigate and improve passivation layer quality and characteristics. In other words, the solar cell backside passivation layer is not subject to a thermal anneal for base/emitter formation (e.g., dopant drive-in), thus removing anneal temperature restraints for the passivation layer (resulting in increased passivation layer material selection options) and avoiding possible passivation layer damage caused during the base/emitter formation anneal (in some instances certain passivation layers are temperature sensitive, e.g., aluminum oxide, and may experience unfavorable effects during high temperature processing). Further, a dopant agent etch back, may also remove damage (e.g. laser damage) from the solar cell absorber itself caused during base/emitter region formation.

[0377] The base and emitter dopant etch strip methods described in detail herein provide for the low damage, high efficiency, and low cost fabrication of silicon back contact solar cells and particularly thin silicon back contact solar cells. Etch strip processes may utilize a wet etching process to remove doping layer and include, but are not limited to, wet etch using aqueous HF or vapor HF, dilute KOH, etc. Importantly, these fabrication flows perform an annealing process for base and emitter region formation before backside passivation layer deposition (e.g., a backside passivation layer such as aluminum oxide, amorphous silicon, amorphous silicon and silicon oxide, aluminum oxide and silicon oxide, or aluminum oxide and silicon nitride). Further, doping oxides, such as those shown as aluminum oxide shown as APCVD boron-doped aluminum oxide herein, may be doping oxides such as silicon oxide for example APCVD boron-doped silicon oxide depending on etchant.

[0378] Importantly, the detailed process flows provided are for descriptive purposes and one skilled in the art may combine, add or remove, alter, or move within an overall process flow the various processing steps disclosed. In other words, elements from each of these process flows may be combined together or with other known solar cell manufacturing methods. Commonalities and variations among the detailed flows may be combined, removed, or otherwise adjusted consistent with solar cell fabrication practice. The described materials, such as passivation materials (e.g., backside passivation dielectric may be aluminum oxide plus silicon oxide), dopants, and metallization materials and processes, such as etching, annealing, deposition (e.g., atmospheric pressure vapor deposition APCVD, plasma enhanced chemical vapor deposition PECVD, atomic layer deposition ALD, etc.), and contact opening processes may be substituted with known materials and processes consistent with solar cell fabrication methods. Solar cell processing factors to consider when determining process flow include, but are not limited to: tool count, capital expenditure, fabrication complexity, temperature considerations. For example, with reference to Fig. 50A replacing processing in Tool 7 (Screen Print Al/Si Paste to Form Patterned M1; Dry/Burn-off/Cure Using Integrated In-Line Furnace; In-Line Test) with a combination of the processing in Tool 8 PVD, Tool 9, and Tool 10 of Fig. 60.

[0379] Further, although not shown, additional backend processing steps such as annealing may be performed. For example, an annealing step of approximately 350° to 450°C in, for example, forming gas, nitrogen, or a vacuum environment may be performed after frontside passivation (for example Al₂O₃ deposition). With reference to Fig. 50A, this annealing may be performed:

1. In Tool 12;
2. Using a separate Tool after Tool 12;
3. Integrated with Tool 14; or
4. After Tool 15

[0380] These processing methods may reduce overall tool count for both monolithic solar cells formed from bulk wafers or epitaxially grown wafers. Briefly, the process flows following may be described as: Figs. 50 through 53 show solar cell fabrication process flow embodiments for the formation of a back contact back junction solar cell utilizing a triple print dopant paste process for field emitter, base, and emitter formation; Figs. 54 through 56 show solar cell fabrication process flow embodiments for the formation of a back contact back junction solar cell utilizing a double print dopant paste process for base and emitter formation; Figs. 57 through 59 show solar cell fabrication process flow embodiments for the formation of a back contact back junction solar cell utilizing a cascade process (deposition followed by patterning) forming field emitter, emitter, and base regions; Figs. 61 and 62 show solar cell fabrication process flow embodiments for the formation of a back contact back junction solar cell utilizing a single cascade process and tunnel contacts; and Fig. 63 shows a solar cell fabrication process flow embodiment for the formation of a back contact back junction solar cell utilizing a single cascade process and tunnel contacts starting with an epitaxial thin film silicon substrate formation.

[0381] Figs. 50A through 50B are solar cell fabrication process flows for the formation of a back contact back junction solar cell utilizing a triple print dopant paste process for field emitter, base, and emitter formation. In Tool 2 of Fig. 50A three dopant pastes are pattern printed on the solar cell backside: a field emitter paste, an emitter paste, and a base window (paste). For example, dopant pastes may be inkjet or screen printed among other known pattern paste deposition methods in Tool 2. For example, dopant pastes may

be silicon nano-particle pastes among other known paste compositions such as doped oxide paste. Field emitter paste, emitter paste, and base window pastes may be concurrently printed in an inkjet tool and then concurrently annealed in a single furnace tool – thus concurrently forming field emitter, emitter, and base regions on the backside surface of the solar cell. Alternatively, these pastes may be individually printed and annealed – in other words an annealing process after each individual dopant print. The solar cell back surface is then wet etch stripped and cleaned to remove remaining dopant agent and doping agent residue. A backside passivation layer is then deposited on the solar cell backside (shown as aluminum oxide but also be other passivation materials including aluminum oxide with silicon oxide). Base and emitter contacts are opened through the passivation layer to corresponding underlying base and emitter regions and additional solar cell fabrication steps may be performed.

[0382] Additional fabrication steps, as described herein and similar throughout Figs. 50A through 63, include the formation of a first level metallization layer (M1), backplane lamination, an optional front surface thinning etch, texturization and/or clean, frontside passivation, backplane via hole formation, and the formation of a second level metallization layer (M2). iCell scribing may be performed by laser processing or mechanical cutting processes. Solar cell frontside processing may include fabrication steps consistent with the detailed flows described and steps may be deleted, added, or combined with known solar cell fabrication practice. Generally, the fabrication steps of Tools 12 to 15 in the following process flows may be combined or otherwise reduced.

[0383] Fig. 50B is a solar cell fabrication flow consistent with Fig. 50A with the silicon thinning etch, iCell cut, and texture etch and post texture clean steps performed in an alternative sequence and alternative tool combination.

[0384] Figs. 51A through 51B are solar cell fabrication process flows for the formation of a back contact back junction solar cell utilizing a triple print dopant paste process with an in-line furnace (e.g., in-line batch furnace) for base and emitter region formation in Tool 2. Fig. 51A is consistent with the flow of Fig. 50A with an in-line furnace anneal performed in Tool 2 along with dopant paste print. Fig. 51B is consistent with the flow of Fig. 50B with an in-line furnace anneal performed in Tool 2 along with dopant paste print.

[0385] Figs. 52A through 52B are solar cell fabrication process flows for the formation of a back contact back junction solar cell utilizing a triple print dopant paste process with an in-line furnace for base and emitter region formation in Tool 2 and dual frontside surface passivation process in Tool 10 and Tool 11, respectively. Fig. 52A is consistent with the flow of Fig. 51A with a frontside passivation step performed in Tool 10. Fig. 52B is consistent with the flow of Fig. 51B with a frontside passivation step performed in Tool 11.

[0386] Fig. 53 is a solar cell fabrication flow consistent with Fig. 52A with the iCell cut combined with second level metallization layer patterning in Tool 12.

[0387] Figs. 54A through 54B are solar cell fabrication process flows for the formation of a back contact back junction solar cell utilizing a double print dopant paste process for base and emitter formation. As compared to the base and emitter region formation portions of the flow of Fig. 50A using Tool 2, in the flow of Fig. 54A two dopant pastes are pattern printed on the solar cell backside using Tool 2: an emitter paste and a base window (paste). And a field emitter is then deposited across the cell backside using Tool 3 APCVD. Backside base and emitter regions are formed in an annealing process after which the remaining dopants are stripped and the backside surface is cleaned for the deposition of a backside passivation layer. Thus, double print embodiments may reduce the amount of dopant paste used as compared to a triple print embodiment (i.e., two paste prints of base and emitter in a double print process as compared to three paste prints of field emitter, base, and emitter in a triple print process). For example, dopant pastes may be inkjet or screen printed among other known pattern paste deposition methods in Tool 2. For example, dopant pastes may be silicon nano-particle pastes among other known paste compositions such as doped oxide paste.

[0388] Fig. 54B is a consistent with the flow of Fig. 50B and having a double print of base and emitter paste in Tool 2 and field emitter formation in Tool 3.

[0389] Figs. 55A through 55B are solar cell fabrication process flows for the formation of a back contact back junction solar cell utilizing a double print dopant paste process for base and emitter region formation in Tool 2 and dual frontside surface passivation process in Tool 12 and Tool 13, respectively. Fig. 55A is consistent with the flow of Fig.

54A with a frontside passivation step performed in Tool 12. Fig. 55B is consistent with the flow of Fig. 54B with a frontside passivation step performed in Tool 13.

[0390] Fig. 56A is a solar cell fabrication flow consistent with Fig. 55A with the iCell cut combined with second level metallization layer patterning in Tool 14.

[0391] Fig. 56B is a solar cell fabrication flow consistent with Fig. 56A and having a separated double print with the addition of base window patterning. In some instances, this flow may be advantageous to reduce cross-doping of doping regions. Emitter contact dopant paste is printed in Tool 2, field emitter is deposited in Tool 3, base windows are opened in Tool 4, and base contact dopant paste is printed in Tool 5 thus physically separating the emitter contact dopant paste and based contact dopant paste by the APCVD field emitter layer.

[0392] Figs. 57A through 57B are solar cell fabrication process flows for the formation of a back contact back junction solar cell utilizing a cascade process (deposition followed by patterning) forming field emitter, emitter, and base regions (shown in Tools 2 through 6). Specifically, the process flow of Fig. 57A shows an example of an APCVD cascade dry base flow with all dry AlOx and ns laser ablation processing for base and emitter region formation. As compared to dopant paste, the cascade flows provided blanket deposit a field emitter dopant followed by patterning and blanket deposition of emitter and base dopants. A concurrent annealing step, shown in Fig. 57A as Tool 4, simultaneously forms backside base and emitter regions process after which the remaining dopants are stripped and the backside surface is cleaned for the deposition of a backside passivation layer. Considerations relating to this fabrication flow may include cost reduction as compared to a dopant paste based method, avoiding and/or reducing cross doping, an increase in the quantity of tools, and laser damage caused by laser ablation to open emitter and base solar cell backside surface regions for doping (for example Tool 3 and Tool 5 shown in Fig. 57A).

[0393] Fig. 57B is a consistent with the flow of Fig. 50B and having a cascade process (deposition followed by patterning) for field emitter, emitter, and base formation.

[0394] Figs. 58A through 58B are solar cell fabrication process flows for the formation of a back contact back junction solar cell utilizing are solar cell fabrication process flows for the formation of a back contact back junction solar cell utilizing a cascade process

(deposition followed by patterning) forming field emitter, emitter, and base regions in Tools 2 through 6 and dual frontside surface passivation process in Tool 15 and Tool 16, respectively. Fig. 58A is consistent with the flow of Fig. 57A with a frontside passivation step performed in Tool 15. Fig. 58B is consistent with the flow of Fig. 57B with a frontside passivation step performed in Tool 16.

[0395] Fig. 59 is a solar cell fabrication consistent with Fig. 57A with the iCell cut combined with second level metallization layer patterning in Tool 17.

[0396] Fig. 60 is a solar cell fabrication process flows for the formation of a back contact back junction solar cell utilizing a single cascade process (deposition followed by patterning) forming emitter and base regions (shown in Tools 2 through 4) and tunnel contacts (shown in Tool 8). Specifically, the process flow of Fig. 60 shows an example of an APCVD cascade single ablation tunnel contacts flow. Fig. 61 is a solar cell fabrication process flows for the formation of a back contact back junction solar cell utilizing a single cascade process (deposition followed by patterning) forming emitter regions only (shown in Tools 2 through 4) and tunnel contacts (shown in Tool 8).

[0397] Fig. 62 is a solar cell fabrication process flows for the formation of a back contact back junction solar cell utilizing a single cascade process (deposition followed by patterning) forming emitter and base regions (shown in Tools 2 through 4) and tunnel contacts (shown in Tool 8) consistent with the process flow of Fig. 60 and forming an epitaxial thin film substrate (as compared to the starting wafer of the fabrication flow shown in Fig. 60). HF vapor etch in Tool 7 eliminates wet processing. Al cap in Tool 10 may not be required.

[0398] The tunnel contact fabrication process flows of Figs. 60 through 62 may in some instances provide several advantages. For example: a minimum number of materials introduced into the solar cell structure and fabrication flow (as shown only Al₂O₃ used for surface and junction passivation) thus decreasing complexity; no selective emitter (i.e., non-selective emitters and no field emitter) for reduced process flow complexity and cost in the primary flow; high-quality rear surface passivation by stripping the doping layers and subsequently depositing a high-quality rear passivation comprising Al₂O₃; and highest thermal budget after backside passivation and contact junction passivation deposition may be the M2 PVD thermal budget (~325°C).

[0399] Further, thin PVD Al may eliminate paste firing thermal budget risk to the rear side passivation. This has several major advantages and benefits including: high quality ohmic contacts to both n and p regions (superior to Ni inkjet print); ability to deposit tunnel aluminum oxide in situ in the PVD chamber, hence, no added tool for heterojunction contacts (tunnel Al₂O₃ is used for both n-type and p-type contacts) resulting in lower cost; very low contact resistance and near-bulk resistivity of PVD Al enables reduction of the number of via holes improves capital efficiency (less number of via hole laser drilling tools); no NiV capping layer may result in no requirement for metal laser ablation (highly reflective PVD Al is an excellent stopping layer for CO₂ via drill process); and Al M1 patterned using simple screen print wet etch (in dilute HCl).

The disclosed subject matter provides structures and methods for making self aligned contacts for back contact back junction solar cells. Specifically, the disclosed subject matter and corresponding figures provide low-damage, high-efficiency, and low-cost process flows for the formation of thin silicon solar cells using self aligned contacts for back contact back junction (e.g., interdigitated back contact IBC) solar cells. The novel self aligned contact structures described may achieve higher solar cell conversion efficiency. Additionally, solar cell fabrication methods having minimal or reduced process steps for the formation of solar cell structures with self aligned contacts are described.

The term self aligned describes cell structure such that the heavy doping of n⁺ and p⁺ areas under the base and emitter metal contacts are self-aligned with respect to the contact openings – such as that shown in **Figs. 63A** through **63D**. Fig. 63A is a cross-sectional diagram of a selective emitter solar cell with a self aligned contact structure having a dopant diffusion region with higher doping levels (e.g., greater than 1E18 cm⁻³) just below the metal to silicon absorber contact. Self aligned contact structures may provide higher solar cell efficiency by having heavily doped regions (n and p type) in silicon for improved metal/Si contact resistance and lower surface recombination velocity at metal/Si contact and by minimizing heavy doping areas (e.g., doping greater than 1E18 cm⁻²) in the solar cell thus reducing the overall saturation current density. Alternatively, self aligned contact structure disclosed herein may also be formed by using hetero/tunneling contacts through a barrier layer in between metal and Si – such as that

shown in Fig. 63B. Fig. 63B is a cross-sectional diagram of a solar cell with a self aligned contact structure formed using hetero/tunneling contacts through a barrier layer in between metal and Si.

An advantage of a self aligned structure is that heavy doping areas are limited to only under the contact where they are needed. If the contact open needs to be aligned to the heavy doping with non-self aligned contact structures, the heavy diffusions need to be much wider than the contact open to accommodate for alignment tolerances. As compared to non-self aligned contact structures, the self aligned contact structures provided may have higher efficiency because of two distinct reasons. First, heavy dopings may be deleterious when used under passivation – in other words heavy dopings are more and in some instances only useful when used under poor passivation such as metal. Thus, a self-aligned structure eliminates the areas of heavy doping under high quality passivation. Second, for a non-self aligned structure two openings need to be made: first for doping and second for contact open. If these openings are made using methods which are prone to creating damage in silicon (e.g., in some instances laser processing) a self-aligned structure removes the outer nesting opening and minimizes and in some instances eliminates laser damage from this step. Further, in addition to efficiency advantages, the self-aligned structure may require less process steps and thus reduce cell cost.

Table 1 below shows a front-end process flow for the formation of a selective emitter solar cell having self aligned contacts and a field emitter – such as that shown in Fig. 63A – using a dopant paste step.

1	Saw Damage Removal
2	APCVD Boron Doped Al ₂ O ₃ + Undoped SiO ₂
3	Laser ablation (ns UV and/or ps UV)
4	Dopant Paste (Phos Paste Print -Dry + Boron Paste Print Dry)
5	Diffusion Anneal
6	Wet Etch (eg. Dilute HF, SC1 or dilute KOH based etc)

Table 1. Selective emitter solar cell having self aligned contacts with dopant paste and a field emitter.

Table 1 shows a process flow where self-aligned contact is used for making high efficiency back contact back junction solar cell. Shown, Step 1 is a saw damage removal step to remove damage from a wafer (e.g., a CZ wafer); however, the flows provided are equally applicable to an epitaxially formed silicon substrate processed while on template in which case Step 1 Saw Damage Removal is replace with a porous silicon and epitaxial silicon deposition step as described in detail herein. Thus, in epitaxial embodiments, the front-end processing described occurs on the exposed surface of the template attached epitaxial substrate after which the epitaxial substrate may be released (e.g., mechanical or wet etch release) from the template in back end processing. Importantly, the exemplary process flows provided are described in the context of fabrication high efficiency back contact back junction solar cells for descriptive purposes and one skilled in the art may combine, add or remove, alter, or move within an overall process flow the various processing steps disclosed. In other words, elements from each of the process flows described in the table provided herein may be combined together or with other known solar cell manufacturing methods. For example, with reference to Table 1: the laser contact open shown in Step 3 in can be separated in two steps (for example as shown in Table 2) to form self aligned contacts only for base and emitter contacts separately; the dopant paste printing step shown in Step 4 may have additional third print of undoped paste on top of already printed dopant pastes (for example as shown in Fig. 8). Further, the wet etch step shown in Step 6 of Table 1 and which removes annealed dopant paste may be replaced by a dry HF vapor etch process or the removal Step 6 may be skipped (i.e., removed) entirely for an all-dry front-end process. Further, the laser contact open step shown in Step 6 of Table 1 may be replaced by an etch paste process comprising etch paste deposition, dry, and rinse for a laser free front-end process.

Table 2 below shows a front-end process flow for the formation of a selective emitter solar cell having self aligned contacts using dopant paste and using separate contact open steps.

1	Saw Damage Removal
2	APCVD Boron Doped Al ₂ O ₃ + Undoped SiO ₂
3	Laser ablation (ns UV and/or ps UV)
4	Dopant Paste (Phos Paste Print +Dry)
5	Laser ablation (ns UV and/or ps UV)
6	Dopant Paste (Boron Paste Print +Dry)
7	Diffusion Anenal
8	Wet Etch HF Based /SKIP/HF Vapor

Table 2. Selective emitter solar cell having self aligned contacts with dopant paste and separate contact open steps.

Table 3 below shows a front-end process flow for the formation of a selective emitter solar cell having self aligned contacts with dopant paste and the application of a diffusion barrier.

1	Saw Damage Removal
2	APCVD Boron Doped Al ₂ O ₃ + Undoped SiO ₂
3	Laser ablation (ns UV and/or ps UV)
4	Dopant Paste (Phos Paste Print +Dry + Boron Paste Print Dry)
5	APCVD USG dep
6	Diffusion Anneal
7	Wet Etch HF Based /SKIP/HF Vapor

Table 3. Selective emitter solar cell having self aligned contacts with dopant paste and the application of a diffusion barrier.

Alternatively, the diffusion barrier deposition shown in Step 5 of Table 3 as an APCVD USG deposition may also be an undoped paste print.

The process flow embodiments of Tables 2 and 3 may be used to reduce autodoping from dopant pastes during diffusion anneal.

Table 4 below shows a front-end process flow for the formation of a non abutted junction solar cell – such as that shown in Fig. 63C – having self aligned contacts with diffusion barrier dopant paste print. Fig. 63C is a cross-sectional diagram of a non-abutted junction solar cell with a self aligned contact structure having a dopant diffusion

region with higher doping levels (e.g., greater than $1\text{E}18\text{ cm}^{-3}$) just below the metal to silicon absorber contact.

1	Saw Damage Removal
2	Undoped Paste Print + Dry
3	APCVD Boron Doped Al_2O_3 + Undoped SiO_2
4	Laser ablation (ns UV and/or ps UV)
5	Dopant Paste (Phos Paste Print -Dry + Boron Paste Print Dry)
6	Diffusion Anneal
7	Wet Etch HF Based /SKIP/HF Vapor

Table 4. Non abutted junction solar cell having self aligned contacts with dopant paste print and non abutted junction with diffusion barrier paste print.

Alternatively with reference to the non abutted junction solar cell flow of Table 4, Steps 2, 3, and, 4 of Table 4 may be replaced with two steps of APCVD boron doped silicon oxide (BSG1) deposition followed by picosecond (ps) CO_2 laser – an alternative embodiment referred to as self aligned contacts with dopant paste print and non abutted junction with boron doped silicon oxide by APCVD.

Table 5 below shows the fabrication process flow for a non selective emitter solar cell having self aligned contacts and using phosphorous dopant paste.

1	Saw Damage Removal
2	APCVD Boron Doped Al_2O_3 + Undoped SiO_2
3	Laser ablation (ns UV and/or ps UV)
4	Dopant Paste (Phos Paste Print +Dry)
5	Diffusion Anneal
6	Wet Etch HF Based /SKIP/HF Vapor
7	Laser Ablation (ps UV)

Table 5. Non selective emitter solar cell having self aligned contacts with dopant paste.

Alternatively, Table 6 below shows the fabrication process flow for a non selective emitter solar cell having self aligned contacts and using phosphorus oxychloride POCl_3 (POCl).

1	Saw Damage Removal
2	APCVD Boron Doped Al ₂ O ₃ + Undoped SiO ₂
3	Laser ablation (ns UV and/or ps UV)
4	Diffusion Anneal
5	POCl Diffusion
6	Wet Etch HF Based /SKIP/HF Vapor
7	Laser Ablation (ps UV)

Table 6. Non selective emitter solar cell having self aligned contacts with POCl based diffusion.

Table 7 below shows the fabrication process flow for a non selective emitter solar cell having self aligned passivated base contacts using dopant paste.

1	Saw Damage Removal
2	APCVD Boron Doped Al ₂ O ₃ + Undoped SiO ₂
3	Laser ablation (ns UV and/or ps UV)
4	Dopant Paste (Phos Paste Print +Dry)
5	Diffusion Anneal
6	Wet Etch HF Based /SKIP/HF Vapor
7	ALD Dep (Al ₂ O ₃ , TiO ₂ , Al ₂ O ₃ +TiO ₂)
8	Laser Ablation (ps UV)

Table 7. Non selective emitter solar cell having self aligned passivated base contacts with dopant paste.

Table 8 below shows the fabrication process flow for solar cells having self aligned base tunneling/hetero junction contacts – such as those shown in Fig. 63B.

1	Saw Damage Removal
2	APCVD Boron Doped Al ₂ O ₃ + Undoped SiO ₂
3	Laser ablation (ns UV and/or ps UV)
4	Diffusion Anneal
5	Wet Etch HF Based /SKIP/HF Vapor
6	ALD Dep (Al ₂ O ₃ , TiO ₂ , Al ₂ O ₃ +TiO ₂)
7	Laser Ablation (ps UV)

Table 8. Solar cell having self aligned tunneling/hetero junction contacts.

Table 9 below shows the fabrication process flow for solar cells having self aligned contacts without a heavy diffusion region below the base contact.

1	Saw Damage Removal
2	APCVD Boron Doped Al ₂ O ₃
3	Laser ablation (ns UV) Base Only
4	Wet Etch
5	Diffusion Anneal
6	Wet Etch (eg. Dilue HF, SC1 or dilute KOH based etc)
7	ALD Al ₂ O ₃ , TiO ₂
8	Laser Ablation (ps UV)

Table 9. Solar cell having self aligned passivated base contacts.

Alternatively, the self aligned contact structures and methods described herein may be applied to a

Table 10 below shows a front-end process flow for the formation of a solar cell having self aligned contacts with a field base – such as that shown in Fig. 63D. Fig. 63D is a cross-sectional diagram of a solar cell with field base and a self aligned contact structure having a dopant diffusion region with higher doping levels (e.g., greater than 1E18 cm⁻³) just below the metal to silicon absorber contact. Alternatively, for example, the HF Vapor Step 6 in Table 10 and which removes annealed dopant paste may be replaced with a wet etch step.

1	Saw Damage Removal
2	APCVD Undoped Al_2O_3 + Undoped SiO_2
3	Laser ablation (ns UV and/or ps UV)
4	Dopant Paste (Phos Paste Print -Dry + Boron Paste Print Dry)
5	Diffusion Anneal
6	HF Vapor

Table 10. Solar cell having a field base and self aligned contacts with dopant paste.

Alternatively, Table 11 below shows a front-end process flow for the formation of a solar cell having a field base self aligned contacts with etch paste and dopant paste prints – such as that shown in Fig. 63D

1	Saw Damage Removal
2	APCVD Undoped Al_2O_3 + Undoped SiO_2
3	Etch Paste (Print, Cure, Rinse)
4	Dopant Paste (Phos Paste Print -Dry + Boron Paste Print Dry)
5	Diffusion Anneal
6	HF Vapor

Table 11. Solar cell having a field base and self aligned contacts with etch paste and dopant paste print.

Figs. 64A through 64E is a process flow representation showing cross-sectional diagrams of solar cells at various steps during the fabrication of a abutted junction interdigitated back contact solar cell having self aligned contacts with dopant paste. Fig. 64A shows an aluminum oxide (Al_2O_3) layer deposited (e.g., by APCVD) on a silicon substrate/wafer. The aluminum oxide layer may also have an undoped silicate glass layer. Next, as shown in Fig. 64B a nanosecond (ns or ps) laser opens base and emitter contacts. This step may also include a wet etch to remove any oxide residue (e.g., aluminum silicon oxide residue). Next, as shown in Fig. 64C dopant pastes are paste print in emitter and base regions followed by a diffusion anneal to drive-in/diffuse the dopants and form base and emitter regions. Next as shown in Fig. 64D dopant pastes are

stripped (e.g., by wet etch). Next as shown in Fig. 64E metal is printed on the base and emitter regions and annealed resulting in minimal shunt risk.

Figs. 52A through 65G is a process flow representation showing cross-sectional diagrams of solar cells at various steps during the fabrication of a non abutted junction interdigitated back contact solar cell having self aligned contacts with dopant paste. Fig. 65A shows an aluminum oxide (Al_2O_3) layer deposited (e.g., by APCVD) on a silicon substrate/wafer. The aluminum oxide layer may also have an undoped silicate glass layer. Next, as shown in Fig. 65B a nanosecond (ns) laser opens base contacts. This step may also include a wet etch to remove any oxide residue (e.g., aluminum silicon oxide residue). Next, as shown in Fig. 65C a undoped silicate glass layer is deposited (e.g., by APCVD). Next as shown in Fig. 65D a pico second (ps) laser ablates base and emitter contact openings. Next, as shown in Fig. 65E dopant pastes are paste print in emitter and base regions followed by a diffusion anneal to drive-in/diffuse the dopants and form base and emitter regions. Next as shown in Fig. 65F dopant pastes are stripped (e.g., by wet etch). Next as shown in Fig. 65G metal is printed on the base and emitter regions and annealed resulting in minimal shunt risk.

Figs. 66A through 66E is a process flow representation showing cross-sectional diagrams of solar cells at various steps during the fabrication of a non abutted junction interdigitated back contact solar cell having self aligned contacts with dopant paste using an undoped paste first. Fig. 66A shows a undoped silicon oxide (SiO_2) paste printed on the desired based regions of a silicon substrate/wafer only. Next, as shown in Fig. 66B a doped layer (e.g., doped aluminum oxide layer Al_2O_3 or doped borosilicate glass layer BSG1) and undoped silicate glass (USG) layer is deposited (e.g., by APCVD). The undoped silicate glass layer may have a thickness three to four times thicker as compared to the undoped layer. Next as shown in Fig. 66C a pico second (ps) laser ablates base and emitter contact openings. Next, as shown in Fig. 66D dopant pastes are paste print in emitter and base regions followed by a diffusion anneal to drive-in/diffuse the dopants and form base and emitter regions. Next dopant pastes are stripped (e.g., by wet etch). Next as shown in Fig. 66E metal is printed on the base and emitter regions and annealed resulting in minimal shunt risk.

While the methods to manufacture self-aligned back contact back junction solar cells are described in general context of CZ wafers, these methods are also equally applicable in context of epitaxially grown back contact back junction solar cells. In addition, the methods are applicable to both thick crystalline silicon (e.g., having an absorber thickness in the range of approximately 100um to 200um) as well as thin crystalline silicon back contact back junction solar cells (e.g., having an absorber thickness in the range of approximately 5um to 100um).

Generally and particularly applicable to the process flows represented in the tables below, emitter or base contacts are opened sequentially (in either order) or simultaneously using various field dielectric removal techniques such as using lasers or wet etch or etch paste. And subsequently, depositing the dopant source in the opened contact, driving the dopant into silicon at high temperature, and selectively removing/etching the dopant source while keeping the field dielectric unharmed from the etchant. This leaves the dopant driven into silicon only in the area under where the contact was opened leaving a self-aligned structure.

The methods of manufacturing described may be further categorized by the source of the under-contact dopants. These can be from a dopant paste (for example phosphorous for n-type and Boron for p-type) or deposited films which incorporate dopants in them, for example APCVD deposited Boron or phosphorous doped SiO₂ films. Finally, a hybrid source where N⁺ and p⁺ dopant sources come from APCVD for one type and dopant paste for the other type of dopant. A further subcategory is defined by the technique to etch away/remove the dopant source which is applicable to both wafer and epitaxial based absorbers as well as dopant source categories (dopant paste, APCVC film, and hybrid dopant source). As an example, for oxide based dopant sources such as doped SiO₂, either a wet process with HF can be used or a dry process using HF vapor phase etching may be deployed. If the field area is also SiO₂ then the wet HF selectivity is obtained as a heavily doped SiO_x film may etche much faster than an undoped film. Alternatively the field area stack may contain an Al₂O₃ (e.g., deposited using APCVD as well). This film, once treated at high temperatures for example greater than 900°C, may have high selectivity to HF solution. Alternatively, HF vapor also very selectively etch the dopant source.

Generally, if the contacts are opened simultaneously, then both dopant sources may be screen printed dopant paste. If the contacts are open sequentially, then a deposited film for both contacts or hybrid sources can be utilized.

Table 12 shows a front-end self aligned contact fabrication flow which yields a separated junction and is accomplished using dopant pastes (for example, screen printed dopant pastes). In the separated junction the emitter doping is not abutting the base contact doping and is separated by the background bulk doping of the base. Step 2 shows the deposition of the emitter followed by a cap. And although the emitter source is shown to be an APCVD deposited boron doped Al_2O_3 , it may also be a boron doped SiO_2 layer or another dopant source layer deposited using different means. The first laser ablation (Step 3) is to open up the separation between emitter and base doping such that upon anneal, there is a separation between the junctions. The flow suggests using laser ns UV and ps UV. Pico second green laser, a femto second laser, or etch paste or lithography techniques may also be used to create this base window. If pico second laser is used, it may be followed by a small wet etch of silicon to remove laser damage in silicon. Step 5 of Table 12 may also be done using pico second green laser or a femto second laser. Step 5 is a contact open within the base window for base contact as well as a contact open for the emitter. Both contacts are opened up in the same step - hence the method of printing the dopant source should be a selective print on top of these contacts such as screen printing of the dopant paste (as compared to a blanket deposition of a thin dopant sourced film). Subsequent to anneal to drive the dopants in both contacts in Step 7, the dopant source is either wet etched or etched selectively using HF vapor. In a separate embodiment if the source of the dopant is conductive as with silicon based dopant source, the etching step may be skipped (Step # 8).

1	Saw Damage Removal
2	APCVD Boron Doped Al ₂ O ₃ + Undoped SiO ₂
3	Laser ablation (ns UV and/or ps UV)
4	APCVD Undoped Oxide (Al ₂ O ₃ or SiO ₂)
5	Laser ablation (ns UV and/or ps UV)
6	Dopant Paste (Phos Paste Print -Dry + Boron Paste Print Dry
7	Diffusion Anneal
8	Wet Etch HF Based /SKIP/HF Vapor

Table 12. Self aligned contact fabrication flow yielding a separated junction using dopant pastes.

In another embodiment, if there is risk of co-diffusion during drying or dopant driving the contacts can be opened sequentially. In this scenario, either base or emitter contact is opened first and the corresponding paste is printed and dried. Next, the other contact is opened and the corresponding paste is printed and dried. Finally, both pastes are driven in at the same time. This alternative may avoid cross contamination in the contact during drying and burn.

In a more extreme case if the problem of cross contamination is during the dopant drive, then contact open, dopant paste print, drying/burn, and anneal may be performed on one type of dopant. This sequence is followed by the same steps repeated for the second type of contact. This leads to two different anneals in which case the thermal budgets should be optimized.

In an abutted junction embodiment of the process flow in Table 12, Steps 3 and 4 may be skipped and contacts can be directly opened for both base and emitter.

Finally, in another variation, the field area may be capped by a thin film which is resistant to the dopant source etchant chemistry. In the case where the dopant source is SiO_x based, and the etching chemistry is HF based, the cap layer may be APCVD based Al₂O₃ (undoped or doped) or titanium oxide (TiO₂) or amorphous silicon (a-Si).

Table 13 shows a front end separated junction self aligned solar cell process flow using only APCVD deposited films which serves as dopant sources. This flow follows the same steps as Table 12 (with all the variations described above) until Step 4. At Step

5, only one type of contact is opened first. In this case it is the emitter contact (for an n-type back contact cell). This is followed by an APCVD BSG film which is the dopant source for emitter contact doping (Step 6). Next, the base contact is opened and PSG is deposited using APCVD. In a variation, the sequence of emitter and base contact open can be reversed. An abutted version of the separated junction flow described in Table 13 skips/removes Steps 3 and 4 to create abutted junctions.

1	Saw Damage Removal
2	APCVD Boron Doped Al ₂ O ₃ with/out Undoped SiO ₂
3	Laser ablation (ns UV and/or ps UV)
4	APCVD Undoped Al ₂ O ₃ or Undoped SiO ₂
5	ps Laser Contact Open
6	APCVD- Boron doped SiO ₂
7	ps Laser Contact Open
8	APCVD - Phosphorous doped SiO ₂
9	Diffusion anneal
10	Wet Etch HF Based /HF Vapor

Table 13. Self aligned contact fabrication flow yielding a separated junction using APCVD doped dielectric films.

Table 14 below shows a front end separated junction self-aligned process flow using a hybrid approach. In this approach one of the dopant source is a deposited APCVD film while the other type of dopant source is a printed dopant paste.

1	Saw Damage Removal
2	APCVD Boron Doped Al ₂ O ₃ with/out Undoped SiO ₂
3	Laser ablation (ns UV and/or ps UV)
4	APCVD Undoped Al ₂ O ₃ or Undoped SiO ₂
5	ps Laser Contact Open
6	APCVD- Boron doped SiO ₂
7	ps Laser Contact Open
8	Dopant Paste Print + Dry
9	Diffusion anneal
10	Wet Etch HF Based /HF Vapor

Table 14. Self aligned contact fabrication flow yielding a separated junction using a hybrid APCVD doped dielectric film and phosphorous based dopant paste.

The flow of Table 14 shares the first four steps (along with its variations) with Table 13. In Step 5 of Table 14, the emitter contact is opened. BSG is deposited in Step 6 and Step 7 opens base contact with a laser (note, although, the flow suggests using ps lasers, nano or femto second lasers with different wavelengths are not precluded as long as they meet the contact open requirements). Subsequently, phosphorous based dopant paste is printed, dried in Step 8. Step 9 is an anneal step to drive the dopants from the BSG and from the phosphorous paste to create under-contact doped areas, while step 10 removes the dopant sources based on either wet or HF vapor technique. An abutted version of the separated junction flow described in Table 14 skips/removes Steps 3 and 4 to create abutted junctions.

In a variation the flow of Table 14 the sequence of BSG2 (Step 6) and phosphorous dopant paste (Step 8) is reversed. Base contact is opened first, followed by phosphorous paste. This is in turn followed emitter contact and BSG2 deposition and the remaining flow is similar.

In another variation, the hybrid dopant sources are based on APCVD PSG and dopant paste boron such that the base contact is made with the APCVD deposited doped SiO₂ film while the emitter contact is made using boron based dopant paste. This variation has further variations where the sequence of contact open and its accompanying dopant source has two possibilities.

Table 15 below is a front end process flow showing a variation of the hybrid approach of Table 14 where both dopant paste and doped dielectric films are used as a source of dopants for base and emitter under contact doping.

1	Saw Damage Removal
2	APCVD Boron Doped Al ₂ O ₃ with/out Undoped SiO ₂
3	Laser ablation (ns UV and/or ps UV)
4	APCVD Un Doped Al ₂ O ₃ and/or Undoped SiO ₂
5	Laser ablation (ns UV and/or ps UV)
6	Dopant Paste (Phos Paste Print -Dry)

7	APCVD-Phos doped SiO ₂
8	Diffusion Anneal
9	Laser ablation (ns UV and/or ps UV)
10	APCVD-Boron doped SiO ₂
11	Diffusion Anneal
12	Wet Etch HF Based /SKIP/HF Vapor

Table 15. Self aligned contact fabrication flow yielding a separated junction using a hybrid APCVD doped dielectric film and phosphorous based dopant paste with separated contact open by diffusion anneal which takes out dopant co-diffusion risk

In a variation of Table 15 as compared to Table 14, both emitter and the base contacts are separated by APCVD-PSG and diffusion anneal. This is done to reduce the risk of dopant co-diffusion during diffusion anneal. Co-diffusion is a process when dopant source from base or emitter contact diffusion areas (phos or boron) from dopant paste (phos or boron) moves into other polarity (base or emitter) through gaseous phase. This process may avoided, for example, by putting a solid phase dopant sources (APCVD-PSG) on top of PSG and adding anneal before the next contact emitter contact open step – as shown in Table 15. In some cases, the paste is phosphorous and the base is opened first (for an n-type back contact cell) and in a variation the paste is the boron paste and the emitter is opened first.

A variation of the Table 15 process flow forms abutted junctions by skipping Steps 3 and 4 as shown in Table 16 below. As throughout this disclosure, the variations described in conjunction with Table 15 are equally applicable with the abutted junction flow.

1	Saw Damage Removal
2	APCVD Boron Doped Al ₂ O ₃ with/out Undoped SiO ₂
3	Laser ablation (ns UV and/or ps UV)
4	Dopant Paste (Phos Paste Print -Dry)
5	APCVD-Phos doped SiO ₂
6	Diffusion Anneal

7	Laser ablation (ns UV and/or ps UV)
8	APCVD-Boron doped SiO ₂
9	Diffusion Anneal
10	Wet Etch HF Based /SKIP/HF Vapor

Table 16. Self aligned contact fabrication flow yielding a abutted junction using a hybrid APCVD doped dielectric film and phosphorous based dopant paste with separated contact open by diffusion anneal which takes out dopant co-diffusion risk.

In the variation of Table 15 and 16, the co-diffusion risk may be avoided by eliminating either APCVD-PSG or eliminating diffusion anneal.

Note, all the self-aligned process flows with their variations described so far are equally valid with an epitaxially grown thin film solar cell. A representative process flow which corresponds to the approach outlined in Table 12 (separated junction with dopant paste) is shown in Table 17 for an epitaxial thin film solar cell. Epitaxial flow may use the HF vapor approach to keep the flow mostly dry while the epitaxial absorber is still on the template. All the other embodiments with abutted and separate junctions with hybrid dopant sources or all APCVD dopant sources (shown for CZ wafers) are equally valid for epitaxial solar cells with the modified flow based on Table 16. The present application provides more detailed flows around other aspects of epitaxial formation. The self aligned attribute along with its manufacturing methods can be combined with any of the previously discussed variations of the epitaxial and CZ wafer based process flows.

1	Porous silicon on a thicker template
2	Epitaxial Thin Silicon growth on a template
3	APCVD Boron doped Al ₂ O ₃ + undoped SiO ₂
4	Laser Ablation (ns UV and or ps UV/green)
5	APCVD Undoped Oxide (Al ₂ O ₃ or SiO ₂)
6	Laser Ablation base and emitter contact open (ns UV and or ps UV/green)
7	Dopant paste screen print (Phos paste print/dry + Boron paste print/dry)
8	Diffusion Anneal

9	HF Vapor Etch (can also be dry etch or wet etch which selectively removes dopant source)
10	Al Paste Print/dry
11	Anneal
12	Lamination using a backplane
13	Mechanical release of thin epi sbsorber (Template is separated from absorber and goes for a clean and next reuse)
14	icell cut
15	Texture and clean porous silicon layer
16	Front passivation and ARC (Example Al ₂ O ₃ + SiN)
17	Via drill on the backplane
18	PVD
19	M2 Isolatioin
20	Anneal

Table 17. Self aligned contact fabrication flow yielding a separated junction using dopant pastes based on an epitaxially formed substrate.

[0400] The foregoing description of the exemplary embodiments is provided to enable any person skilled in the art to make or use the claimed subject matter. Various modifications to these embodiments will be readily apparent to those skilled in the art, and the generic principles defined herein may be applied to other embodiments without the use of the innovative faculty. Thus, the claimed subject matter is not intended to be limited to the embodiments shown herein but is to be accorded the widest scope consistent with the principles and novel features disclosed herein.

CLAIMS

What is claimed is:

1. A monolithically-isled solar cell structure comprising:
 - a semiconductor layer with a background doping, comprising a sunlight-receiving frontside and a backside opposite said sunlight-receiving frontside;
 - a patterned first metal layer (M1) on said semiconductor layer backside, said patterned first metal layer having base and emitter metallization self aligned to base and emitter regions on said semiconductor layer backside;
 - an electrically insulating continuous backplane support layer attached to said semiconductor layer backside;
 - a trench isolation pattern partitioning said semiconductor layer into a plurality of solar cell semiconductor regions on said electrically insulating continuous backplane support layer;
 - a patterned second metal layer (M2) on said electrically insulating continuous backplane support layer, said patterned second metal layer having base and emitter metallization; and
 - a plurality of electrically conductive via plugs formed through said electrically insulating continuous backplane support sheet interconnecting select portions of said patterned second-level metal layer to select portions of said patterned first-level metal layer;
 - said patterned first-level metal layer providing solar cell semiconductor region base and emitter metallization and said patterned second-level metal layer providing solar cell semiconductor region to solar cell semiconductor region connection.
2. The monolithically-isled solar cell structure of Claim 1 wherein said semiconductor layer is shaped as a full square.
3. The monolithically-isled solar cell structure of Claim 1 wherein said semiconductor layer is shaped as a square square.

4. The monolithically-isled solar cell structure of Claim 1 wherein said semiconductor layer is shaped as a rectangle.
5. The monolithically-isled solar cell structure of Claim 1 wherein said semiconductor layer is shaped as a polygon.
6. The monolithically-isled solar cell structure of Claim 1 wherein said semiconductor layer is a mono-crystalline silicon layer formed by epitaxial silicon deposition on a mono-crystalline template.
7. The monolithically-isled solar cell structure of Claim 1 wherein said semiconductor layer is a multi-crystalline silicon layer formed by epitaxial silicon deposition on a multi-crystalline silicon template.
8. The monolithically-isled solar cell structure of Claim 1 wherein said semiconductor layer is a mono-crystalline silicon layer formed by using a starting Czochralski (CZ) mono-crystalline wafer.
9. The monolithically-isled solar cell structure of Claim 1 wherein said semiconductor layer is a mono-crystalline silicon layer formed by using a starting Float Zone (FZ) mono-crystalline wafer.
10. The monolithically-isled solar cell structure of Claim 1 wherein said semiconductor layer is a multi-crystalline silicon layer formed by using a starting multi-crystalline wafer.
11. The monolithically-isled solar cell structure of Claim 1 wherein said background doping is an n-type doping to produce a solar cell with n-type semiconductor absorber and base region.

12. The monolithically-isled solar cell structure of Claim 1 wherein said solar cell is a back-contact solar cell.
13. The monolithically-isled solar cell structure of Claim 1 wherein said solar cell is an interdigitated back-contact (IBC) solar cell.
14. The monolithically-isled solar cell structure of Claim 1 wherein said plurality of solar cell semiconductor regions on said electrically insulating continuous backplane support layer comprises an $N \times N = N^2$ array of substantially square-shaped isles with N being an integer equal to or greater than 2.
15. The monolithically-isled solar cell structure of Claim 1 wherein said plurality of solar cell semiconductor regions on said electrically insulating continuous backplane support layer comprises an $N \times M$ array of isles shaped as one or a combination of substantially square-shaped and rectangular-shaped isles with N and M being integers and the product $N \times M$ being an integer equal to or greater than 2.
16. The monolithically-isled solar cell structure of Claim 1 wherein said plurality of solar cell semiconductor regions on said electrically insulating continuous backplane support layer comprises an array of substantially triangular-shaped isles.
17. The monolithically-isled solar cell structure of Claim 1 wherein said plurality of solar cell semiconductor regions on said electrically insulating continuous backplane support layer comprises an array of substantially polygonal-shaped isles.
18. The monolithically-isled solar cell structure of Claim 1 wherein said solar cell produces a voltage scaled up by a factor S and a current scaled down by the same factor S , wherein S corresponds to the number of semiconductor regions connected in electrical series.

19. The monolithically-isled solar cell structure of Claim 1 wherein said patterned first-level metal (M1) comprises a plurality of islands of interdigitated pattern of base and emitter fingers without solar cell busbars.
20. The monolithically-isled solar cell structure of Claim 1 wherein said patterned second-level metal (M2) comprises an interdigitated pattern of base and emitter fingers with solar cell busbars.
21. The monolithically-isled solar cell structure of Claim 1 wherein said patterned second-level metal (M2) is substantially orthogonal or perpendicular to the patterned first-level metal (M1).
22. The monolithically-isled solar cell structure of Claim 1 wherein said semiconductor layer has a thickness in the range of about 1 micron up to about 200 microns.
23. The monolithically-isled solar cell structure of Claim 1 wherein said electrically insulating continuous backplane support sheet has a thickness in the range of about 50 micron up to about 250 microns.
24. The monolithically-isled solar cell structure of Claim 1 wherein said electrically insulating continuous backplane support sheet is a flexible material with relatively close Coefficient of Thermal Expansion (CTE) match to that of said semiconductor layer.
25. The monolithically-isled solar cell structure of Claim 1 wherein said solar cell structure is flexible.
26. The monolithically-isled solar cell structure of Claim 1 wherein said solar cell is packaged in a flexible, lightweight photovoltaic module laminate.

27. The monolithically-isled solar cell structure of Claim 1 wherein said sunlight-receiving frontside has a passivation and anti-reflection coating.
28. The monolithically-isled solar cell structure of Claim 1 wherein the area ratio of said trench isolation pattern openings to said solar cell is relatively small ($<2\%$).
29. The monolithically-isled solar cell structure of Claim 1 wherein the area ratio of sidewall areas of said trench isolation pattern to said solar cell semiconductor region is relatively small ($<2\%$).
30. The monolithically-isled solar cell structure of Claim 1 wherein said electrically insulating continuous backplane support sheet is a flexible prepreg sheet.
31. The monolithically-isled solar cell structure of Claim 1 wherein said electrically insulating continuous backplane support sheet is a flexible aramid fiber and resin prepreg sheet.
32. The monolithically-isled solar cell structure of Claim 1 wherein said semiconductor layer comprise at least one crystalline semiconductor material from the group of silicon, germanium, gallium arsenide, gallium nitride, gallium phosphide, other III-V semiconductors, or a combination thereof.
33. The monolithically-isled solar cell structure of Claim 1 wherein said plurality of solar cell semiconductor regions share said electrically insulating continuous backplane support layer and share a monolithic interconnection structure comprising said patterned first-level metal (M1), said second-level metal (M2), and said plurality of electrically conductive via plugs.
34. The monolithically-isled solar cell structure of Claim 1 wherein said trench isolation pattern is an interconnected pattern of trenches producing a plurality of isles fully partitioned by said trenches and supported by said backplane layer.

35. The monolithically-isled solar cell structure of Claim 1 wherein said plurality of solar cell semiconductor regions comprise a 4 x 4 array of isles, interconnected in electrical series by a combination of said patterned first metal layer (M1) and said patterned second layer metal (M2), resulting in scaling up the voltage and scaling down the current of said solar cell.

36. The monolithically-isled solar cell structure of Claim 1 wherein said plurality of solar cell semiconductor regions comprise a 4 x 4 array of isles, interconnected in a hybrid electrical parallel-series by a combination of said patterned first metal layer (M1) and said patterned second layer metal (M2), resulting in scaling up the voltage and scaling down the current of said solar cell.

37. The monolithically-isled solar cell structure of Claim 1 wherein said plurality of solar cell semiconductor regions comprise a 4 x 4 array of isles, interconnected in electrical parallel by a combination of said patterned first metal layer (M1) and said patterned second layer metal (M2), resulting in improved flexibility of said solar cell.

38. The monolithically-isled solar cell structure of Claim 1 further comprising a bypass diode directly attached to said backside of said solar cell to provide shade management function for said solar cell.

39. The monolithically-isled solar cell structure of Claim 1 further comprising a monolithically-integrated bypass switch to provide shade management function for said solar cell.

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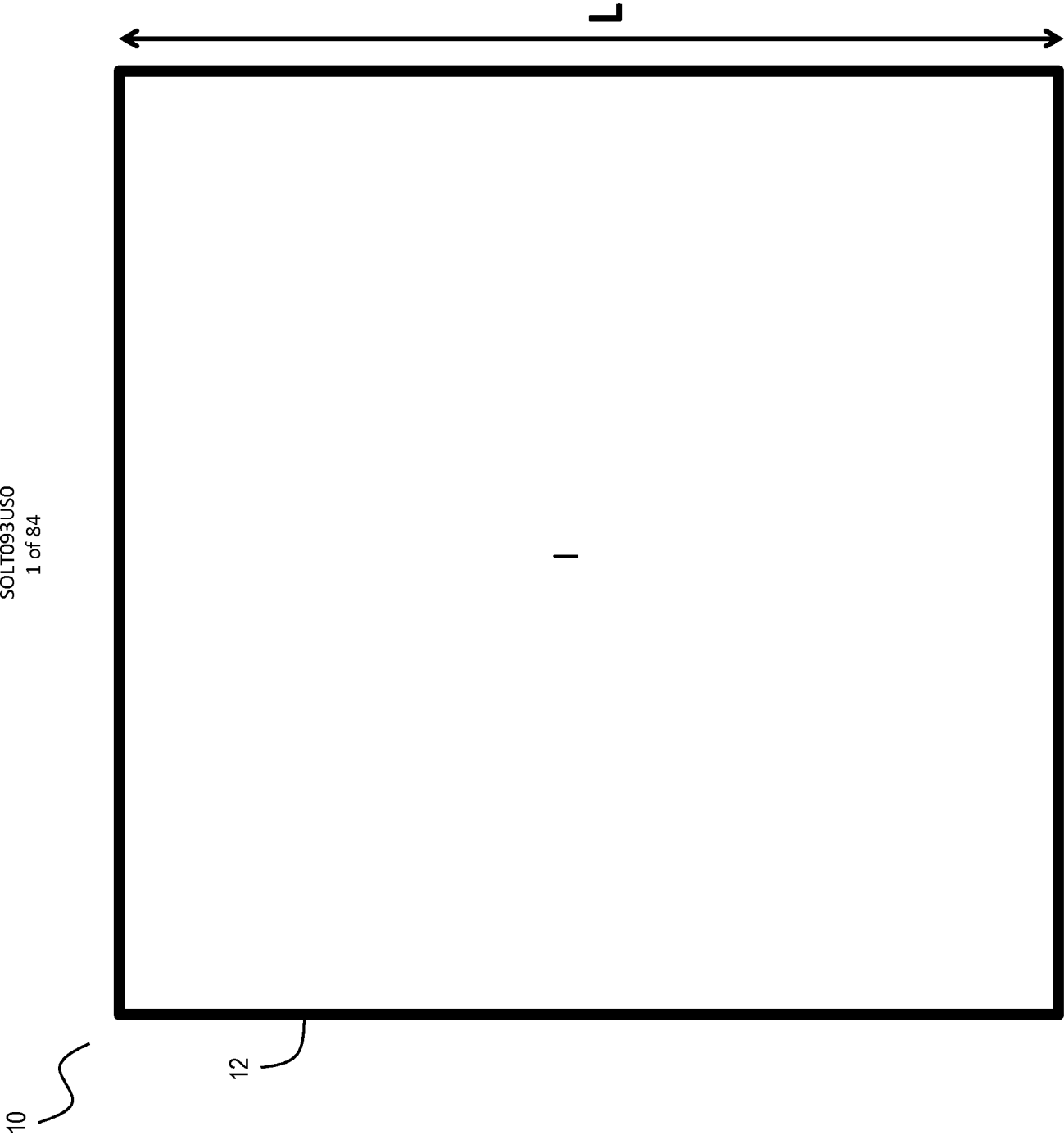


Fig. 1 (prior art)

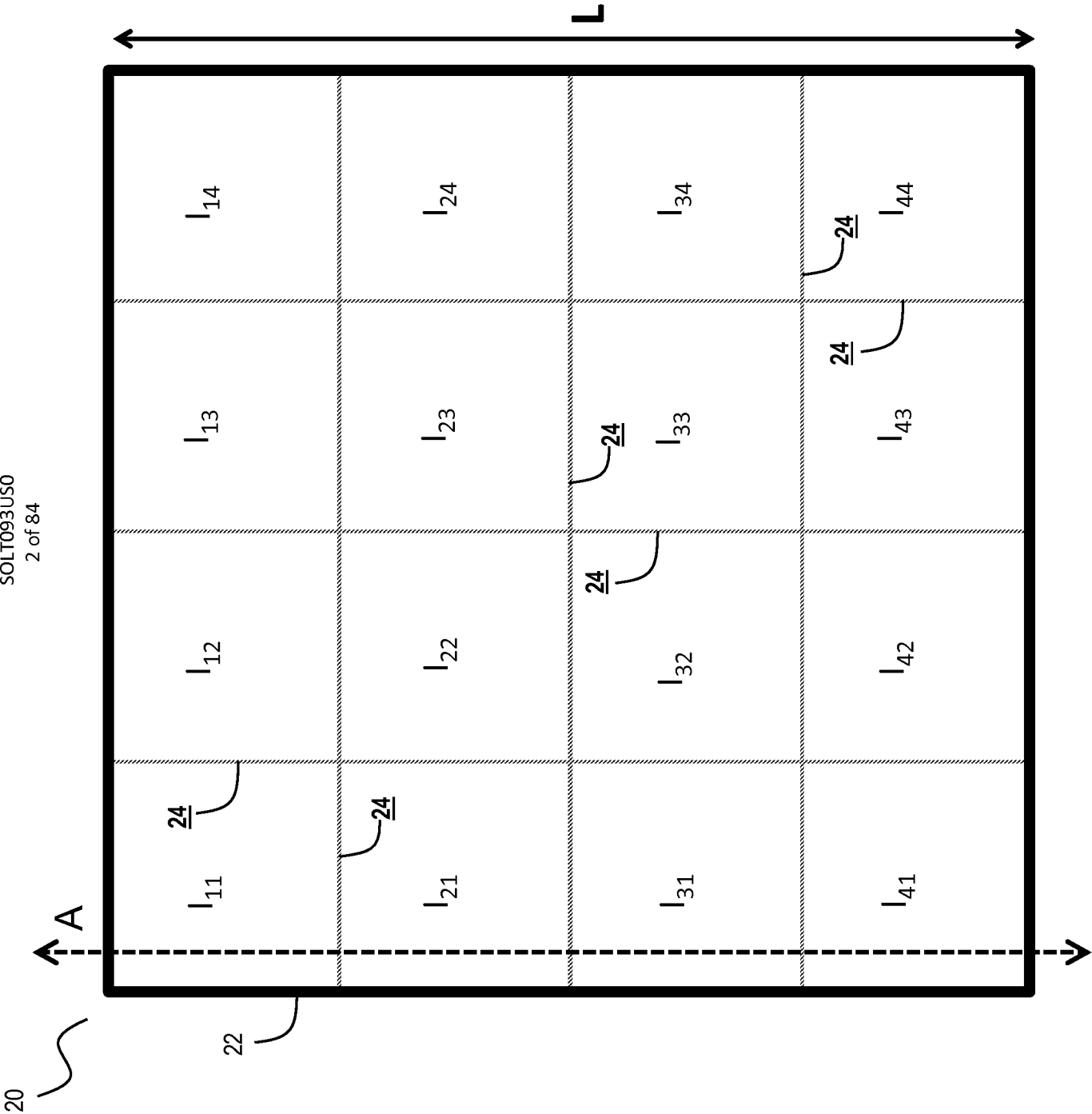


Fig. 2

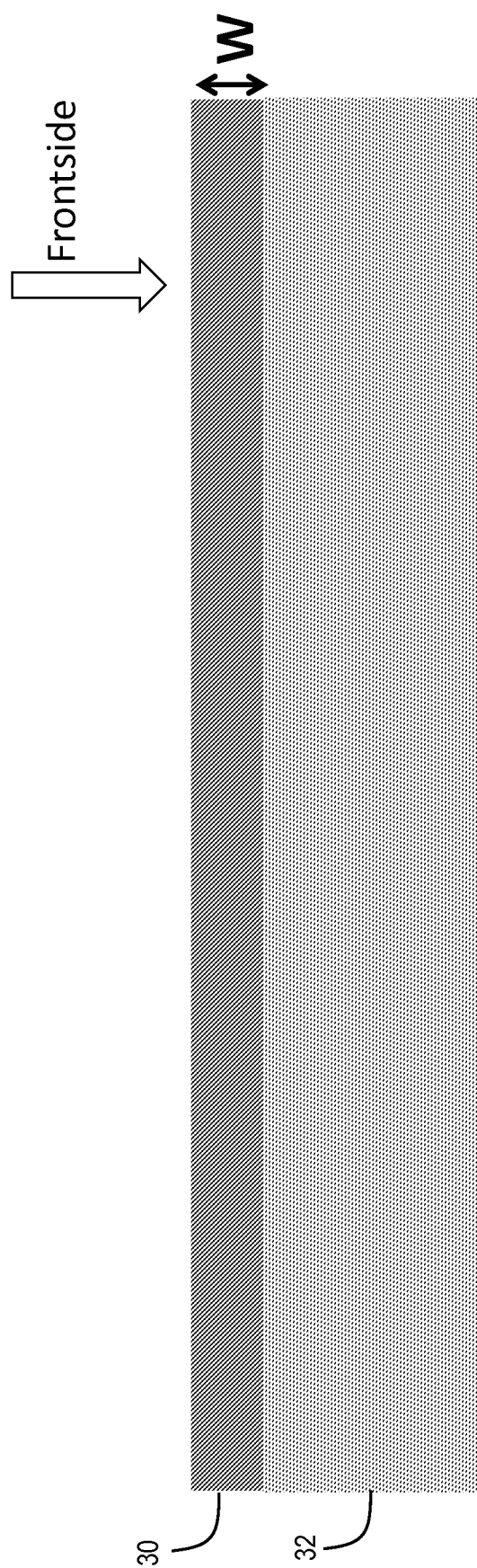


Fig. 3A

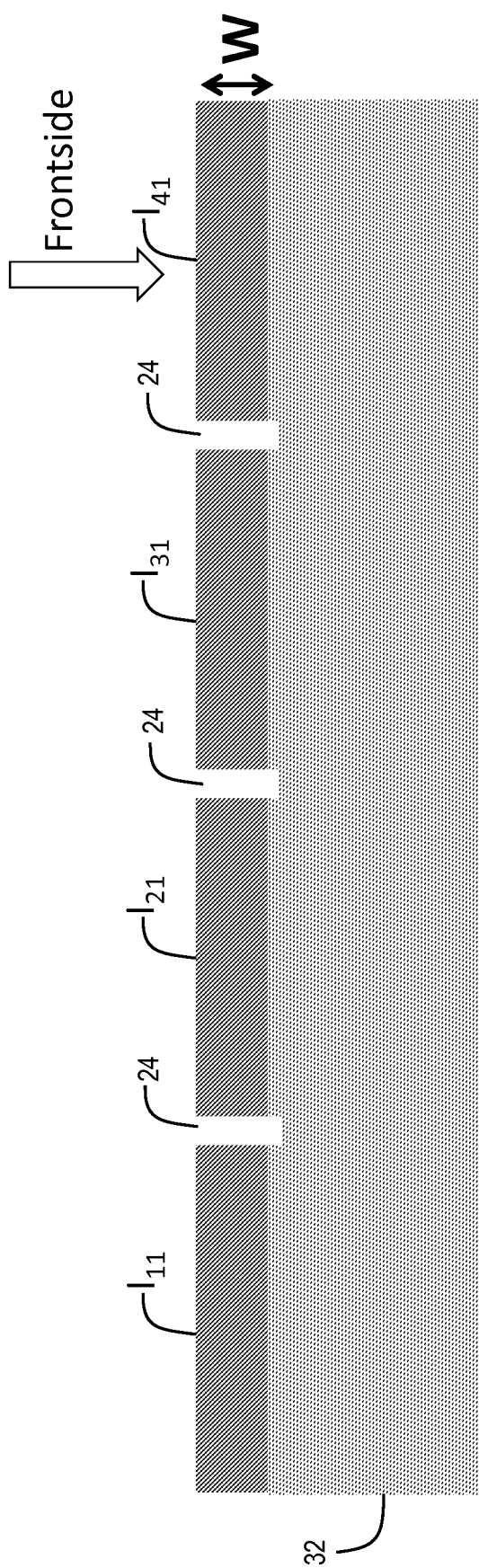


Fig. 3B

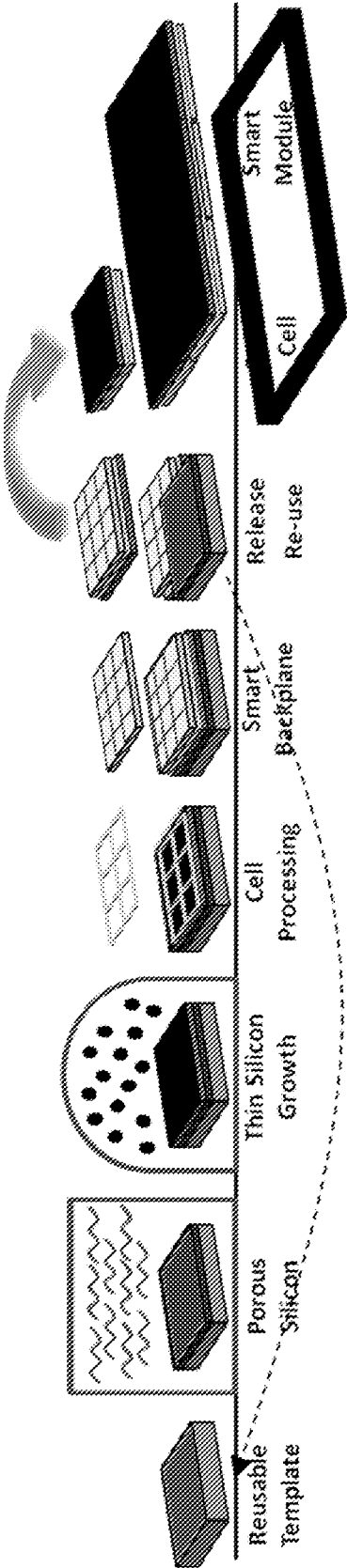


Fig. 4

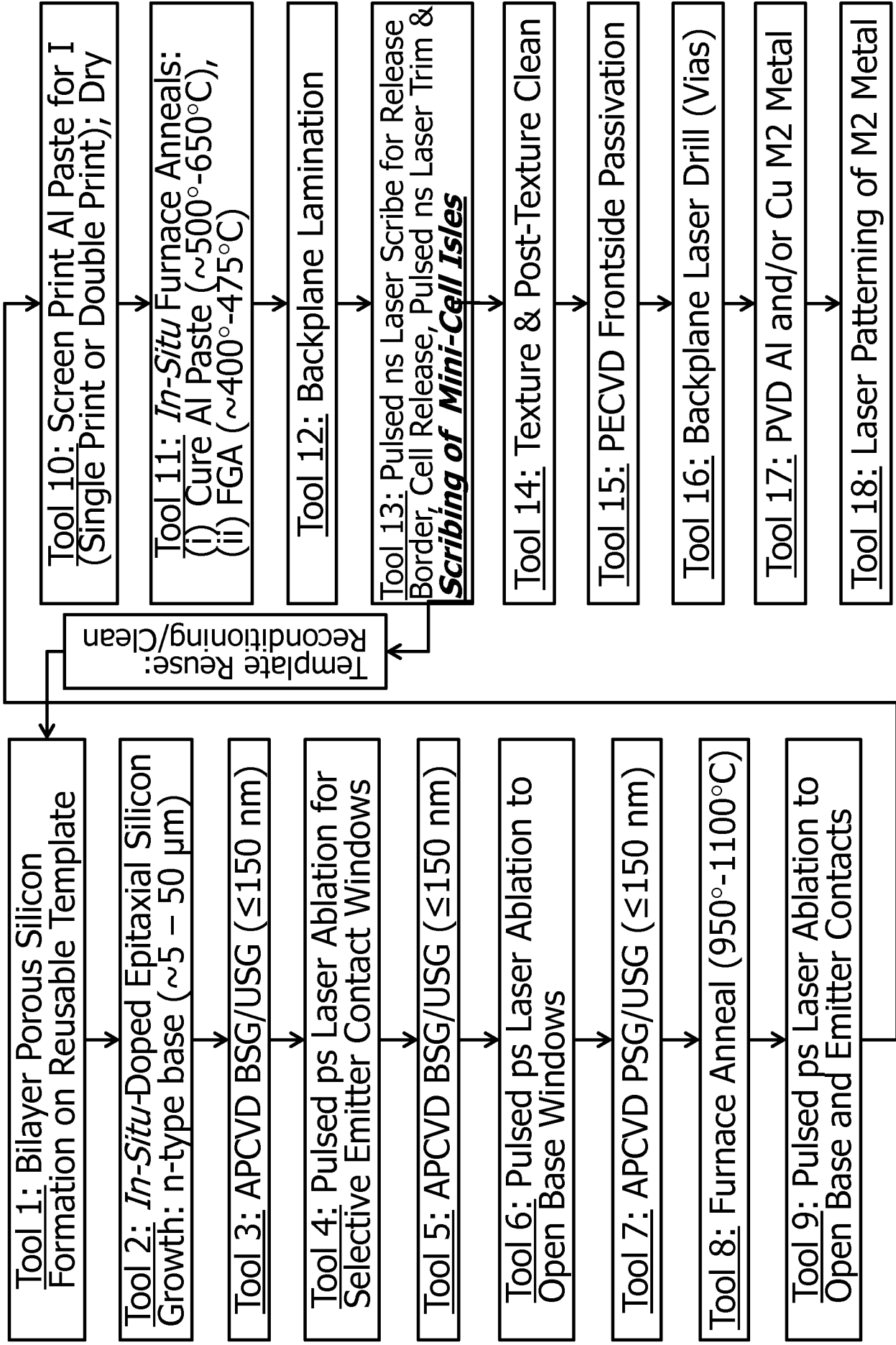


Fig. 5A

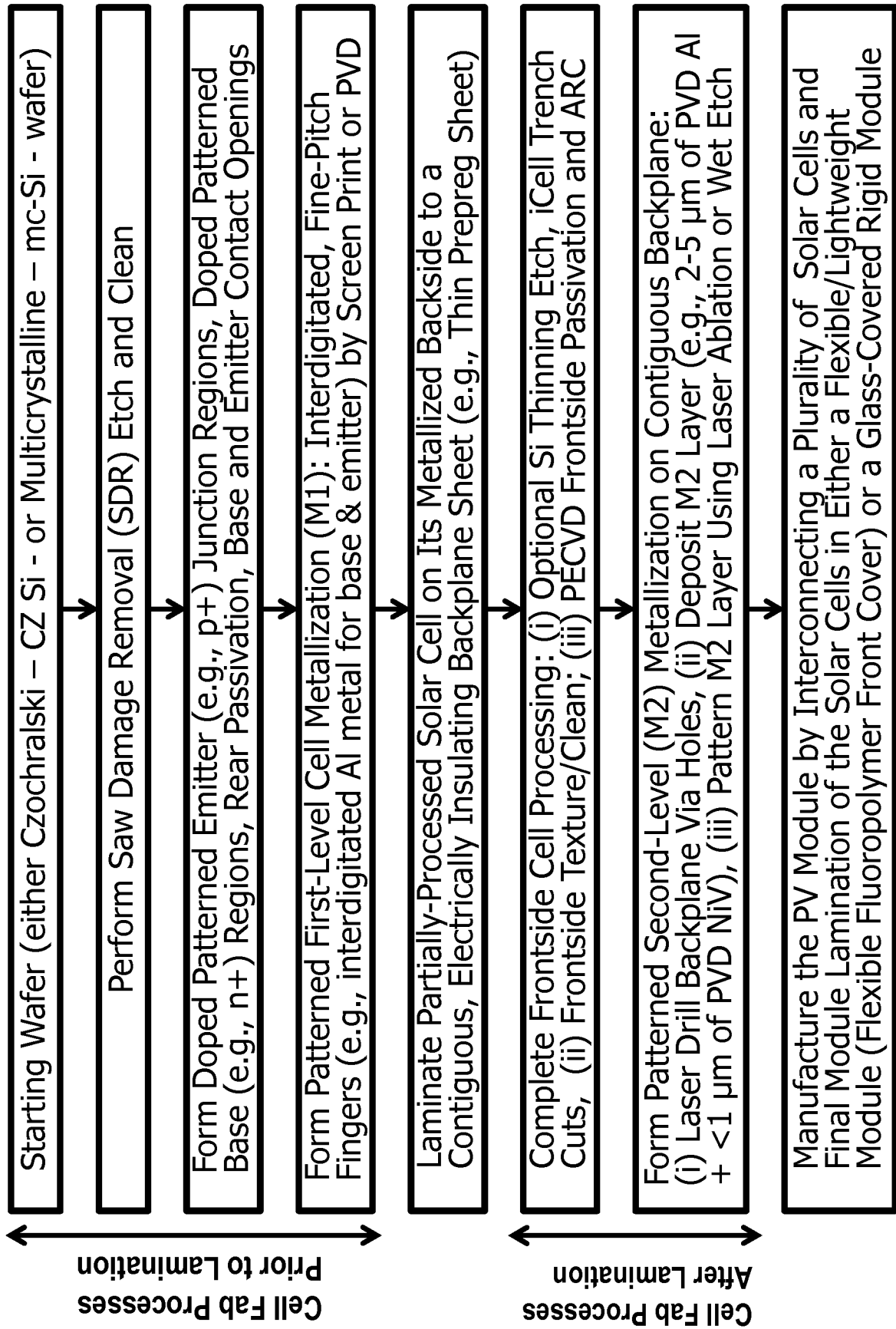


Fig. 5B

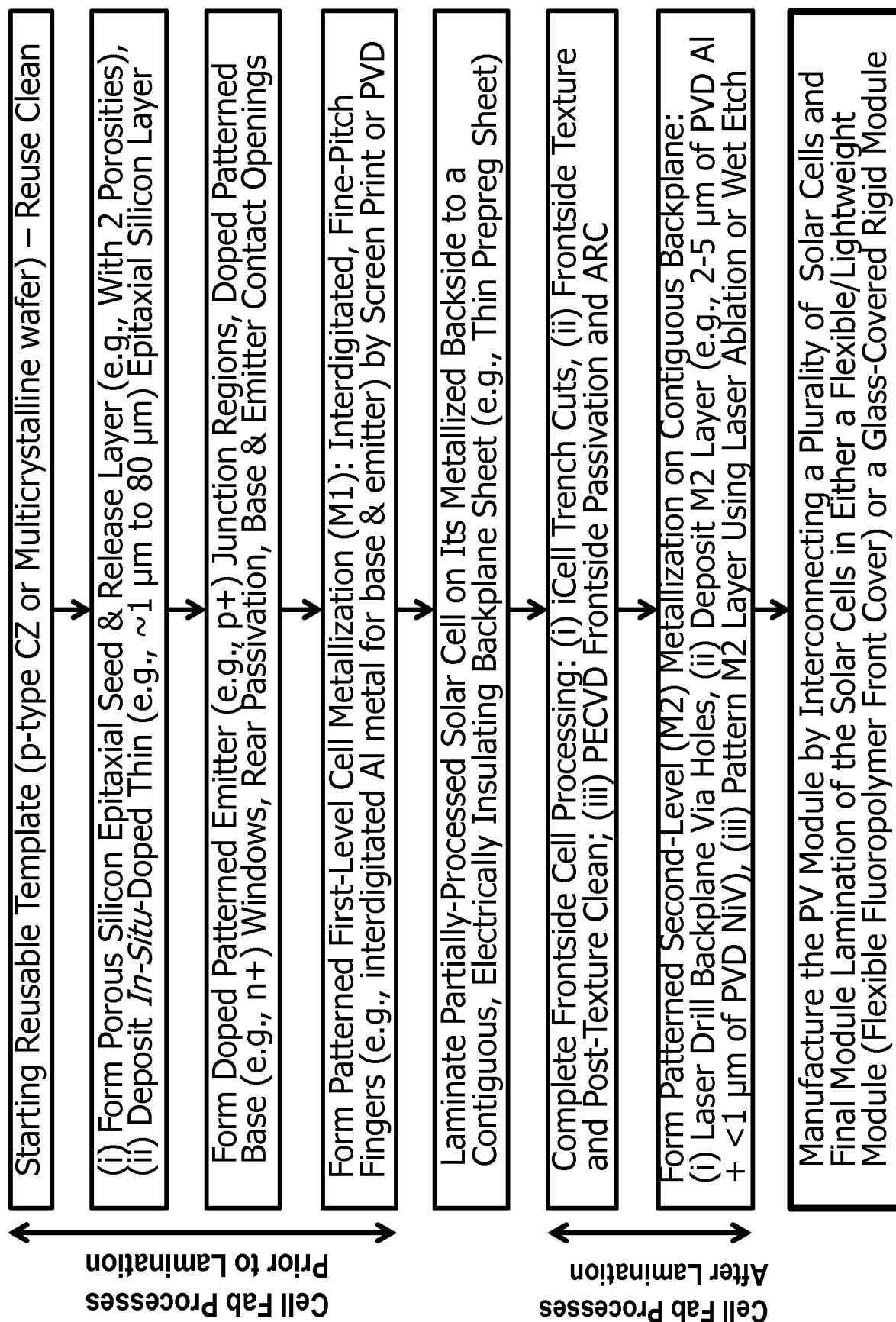


Fig. 5C

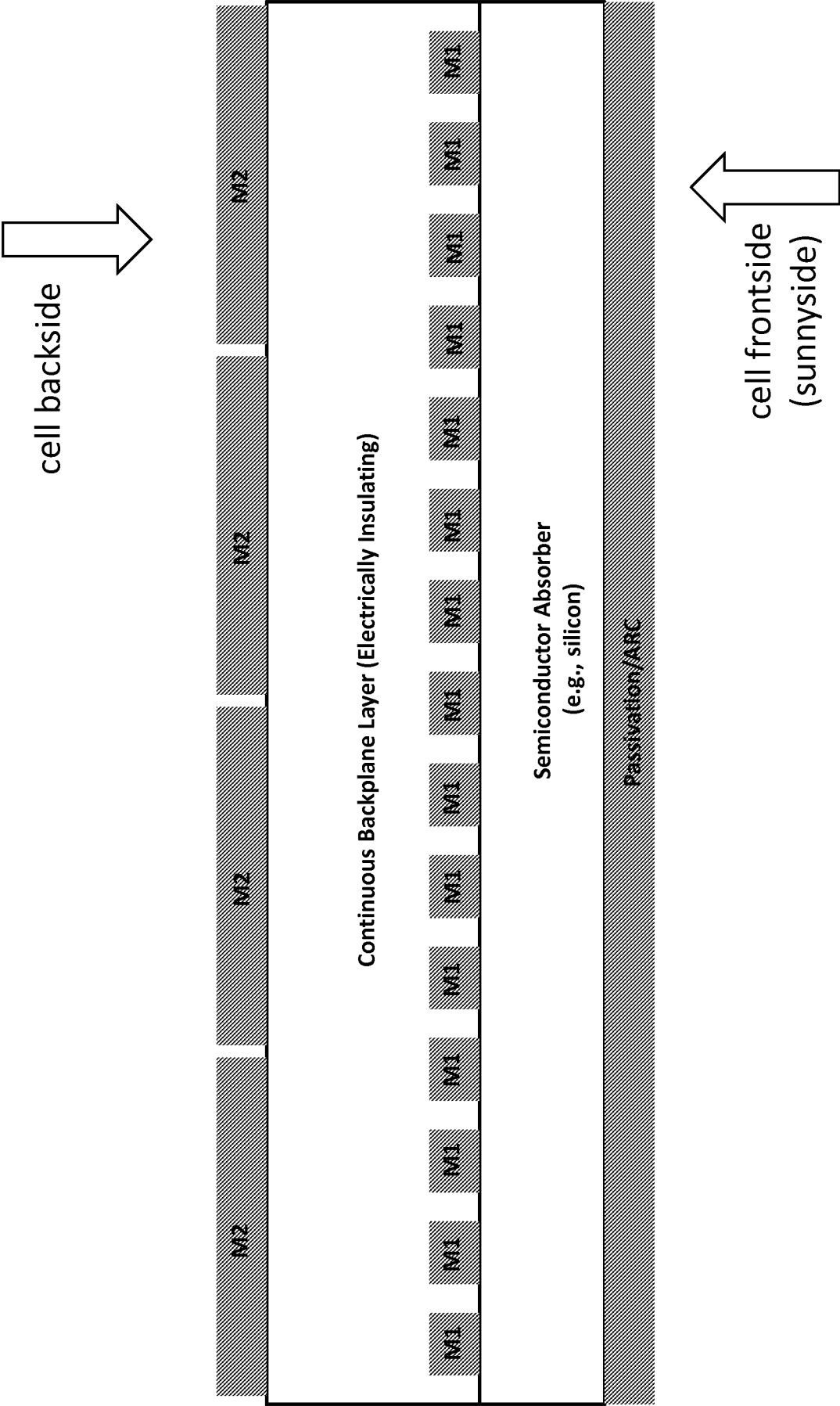


Fig. 5D

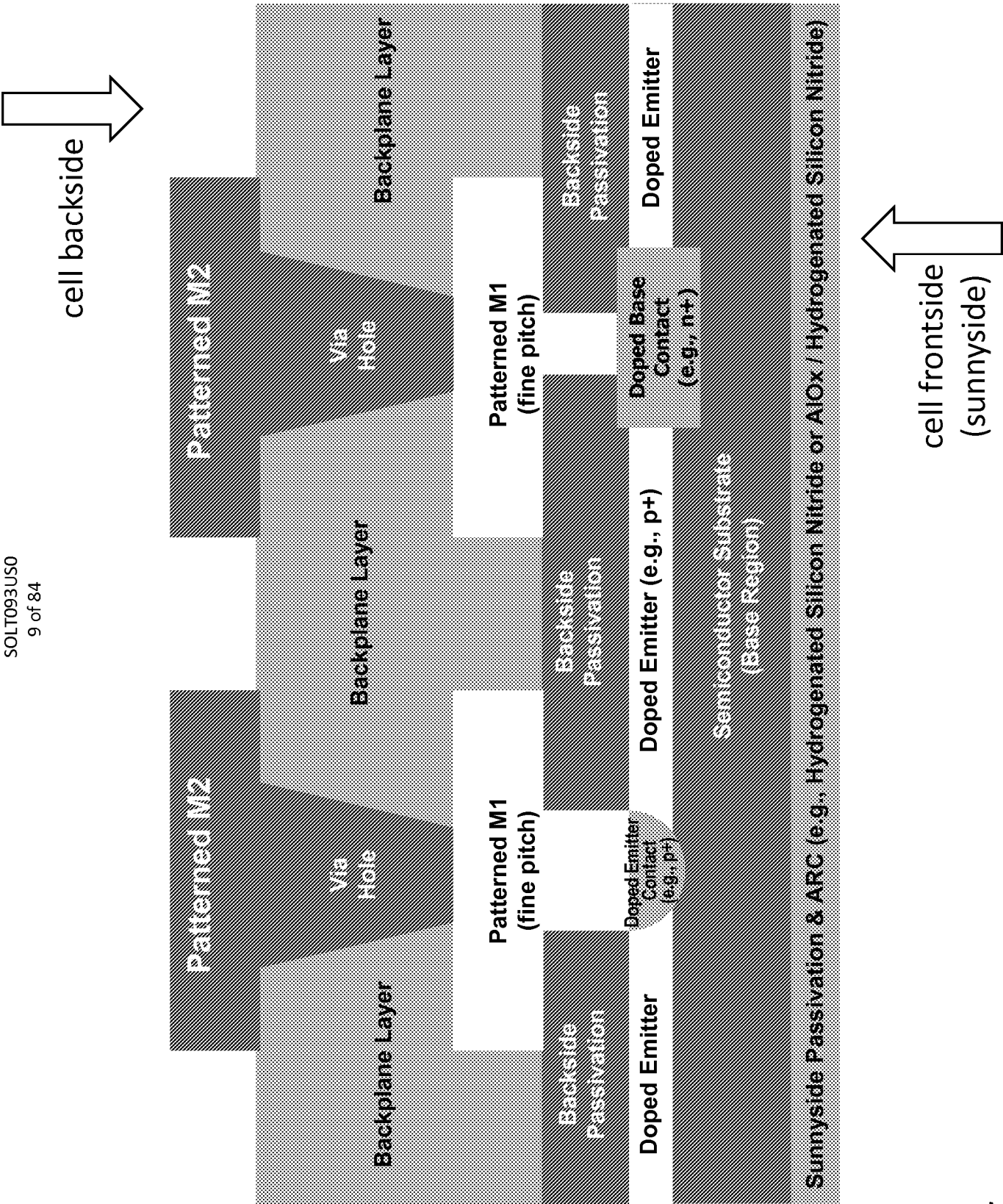


Fig. 5E

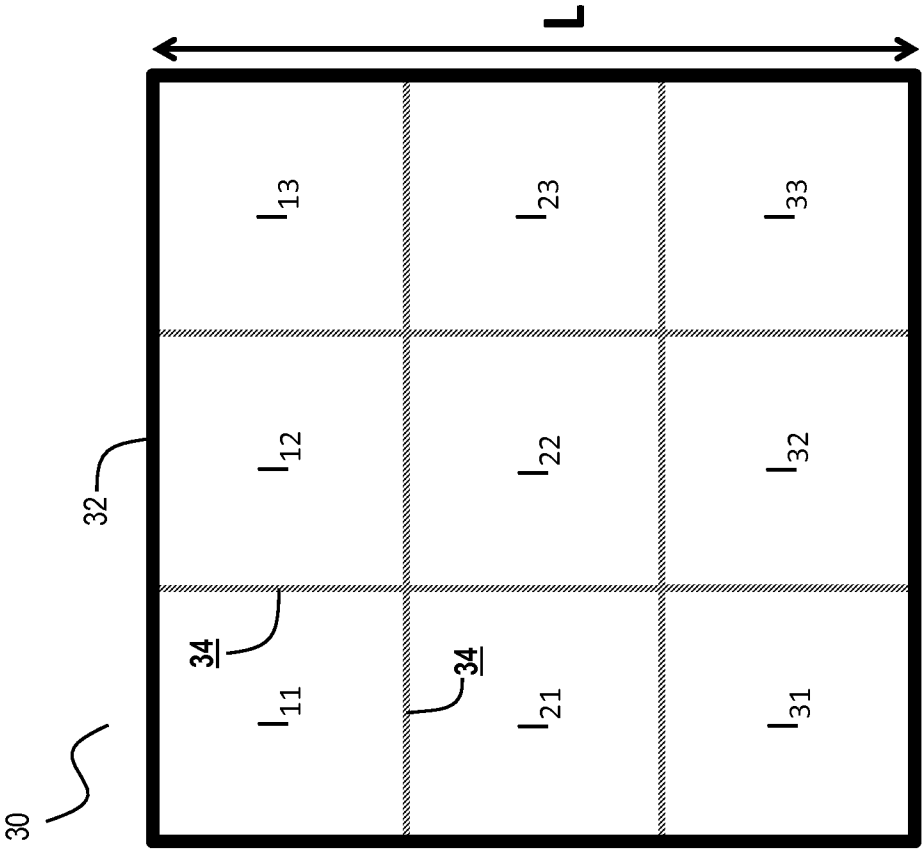


Fig. 6A

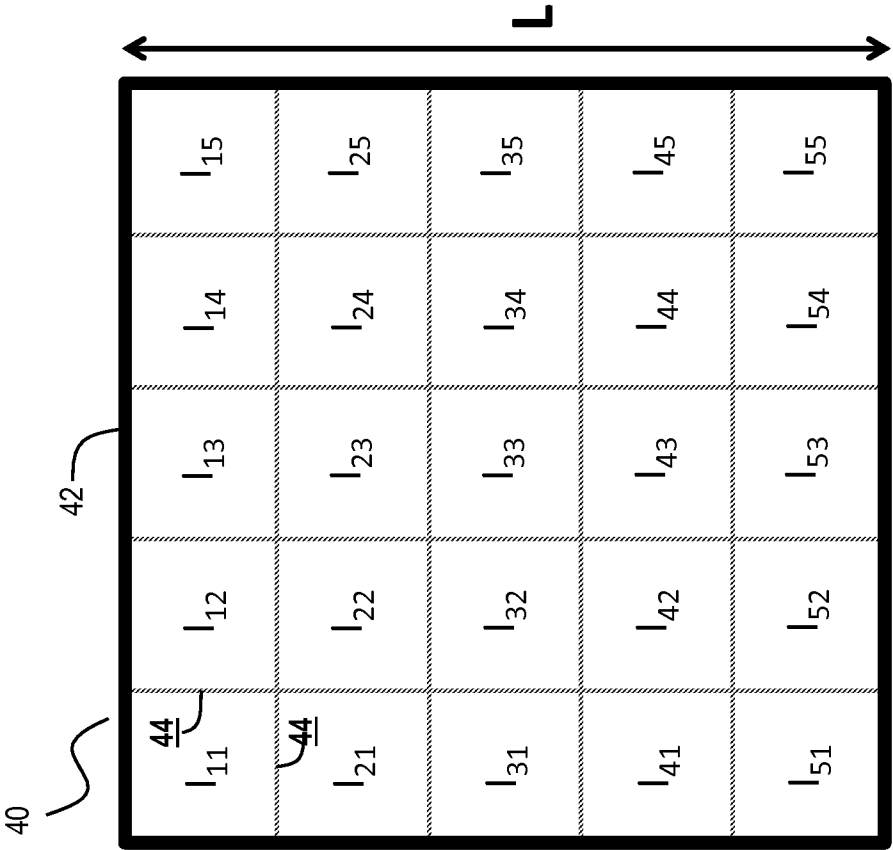


Fig. 6B

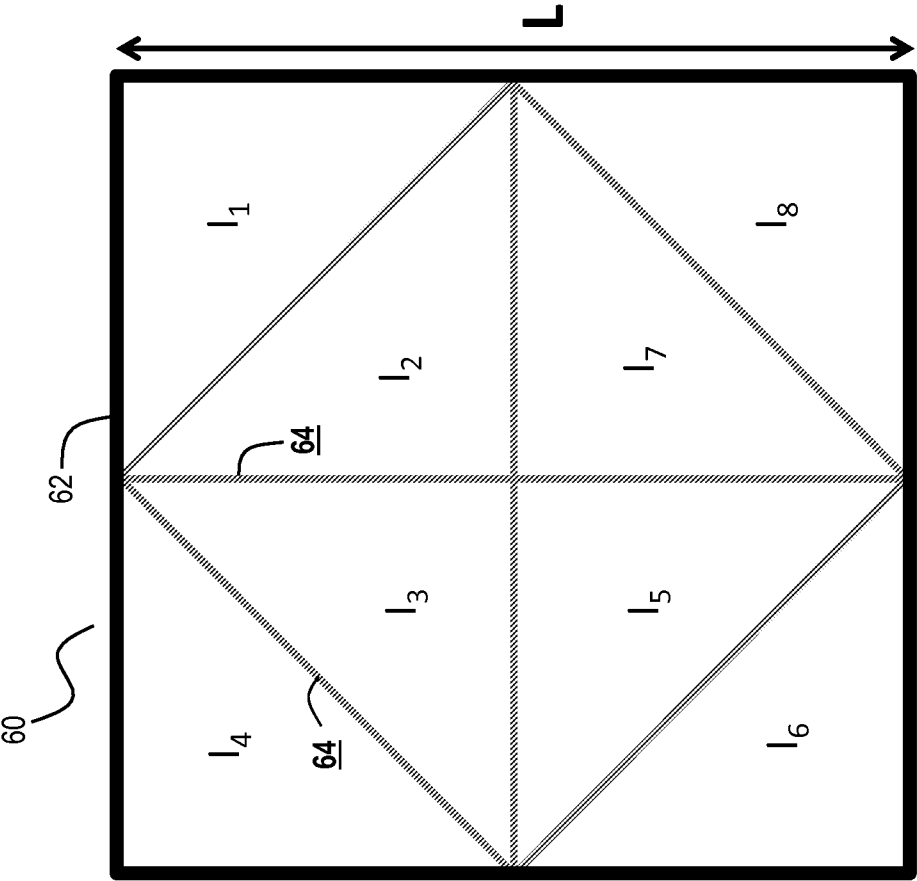


Fig. 7A

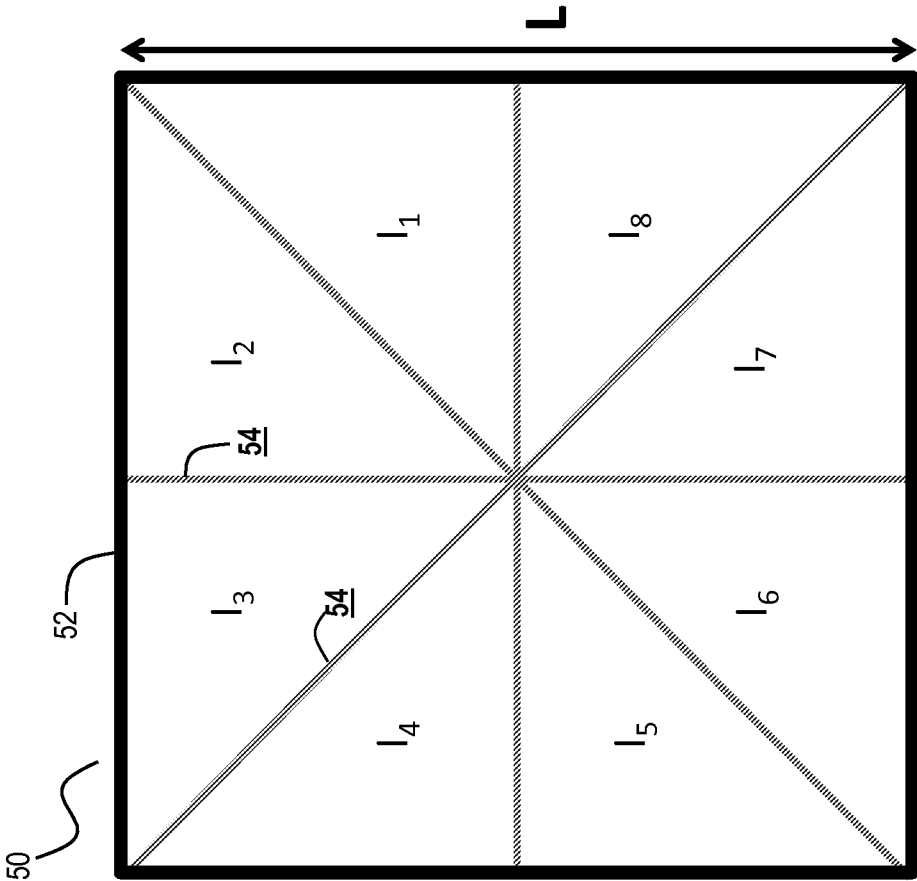


Fig. 7B

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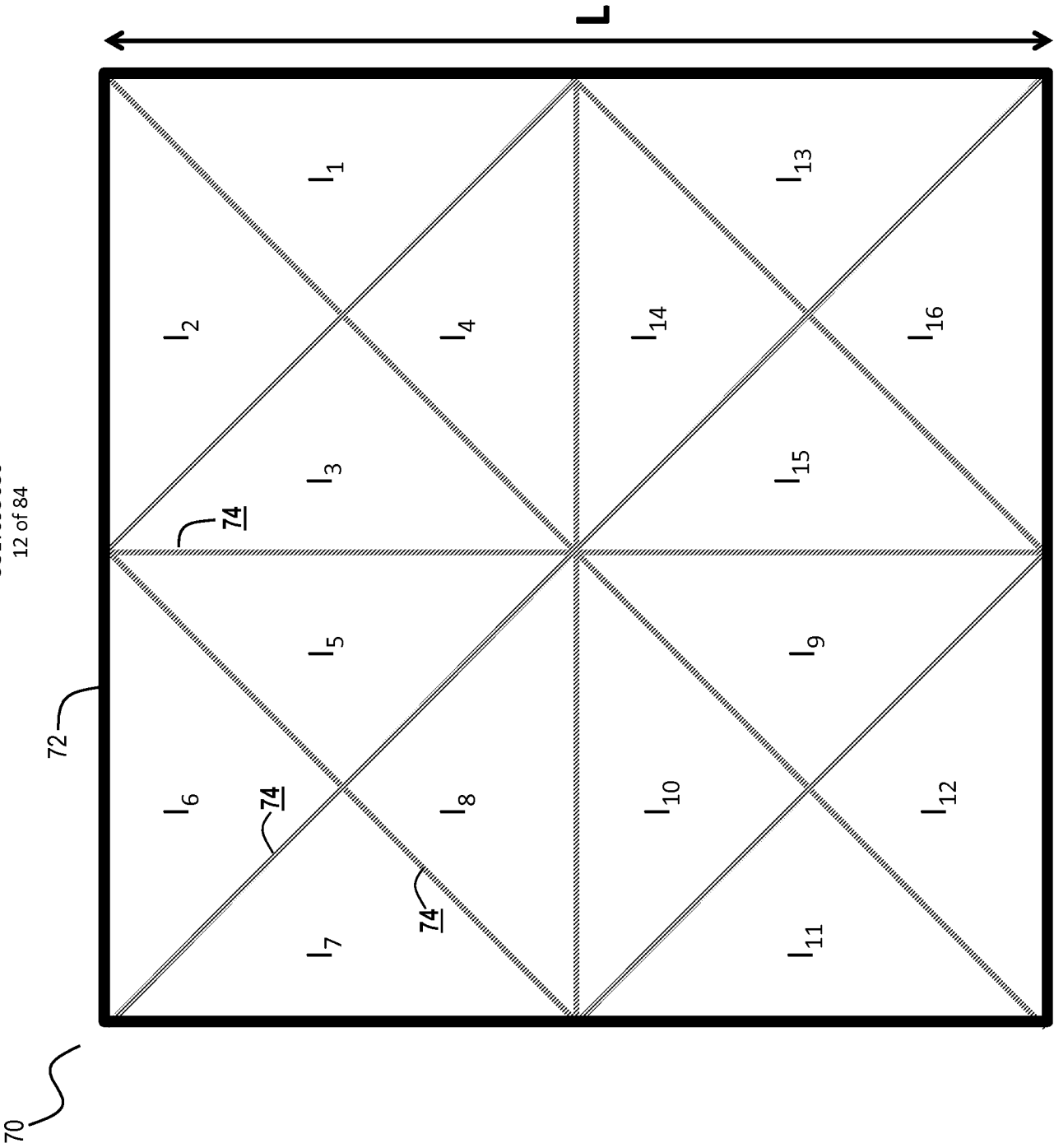


Fig. 7C

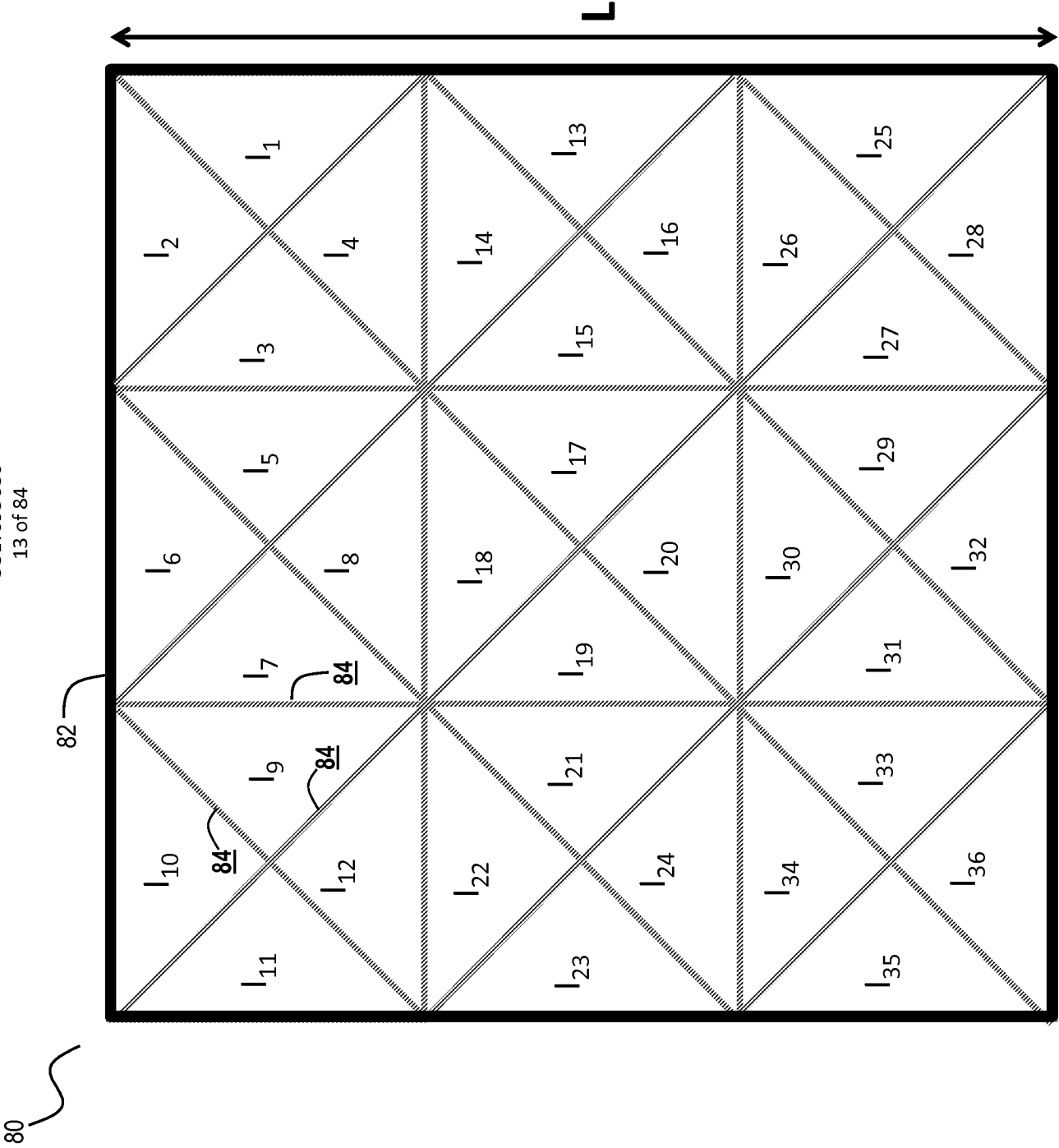


Fig. 7D

L

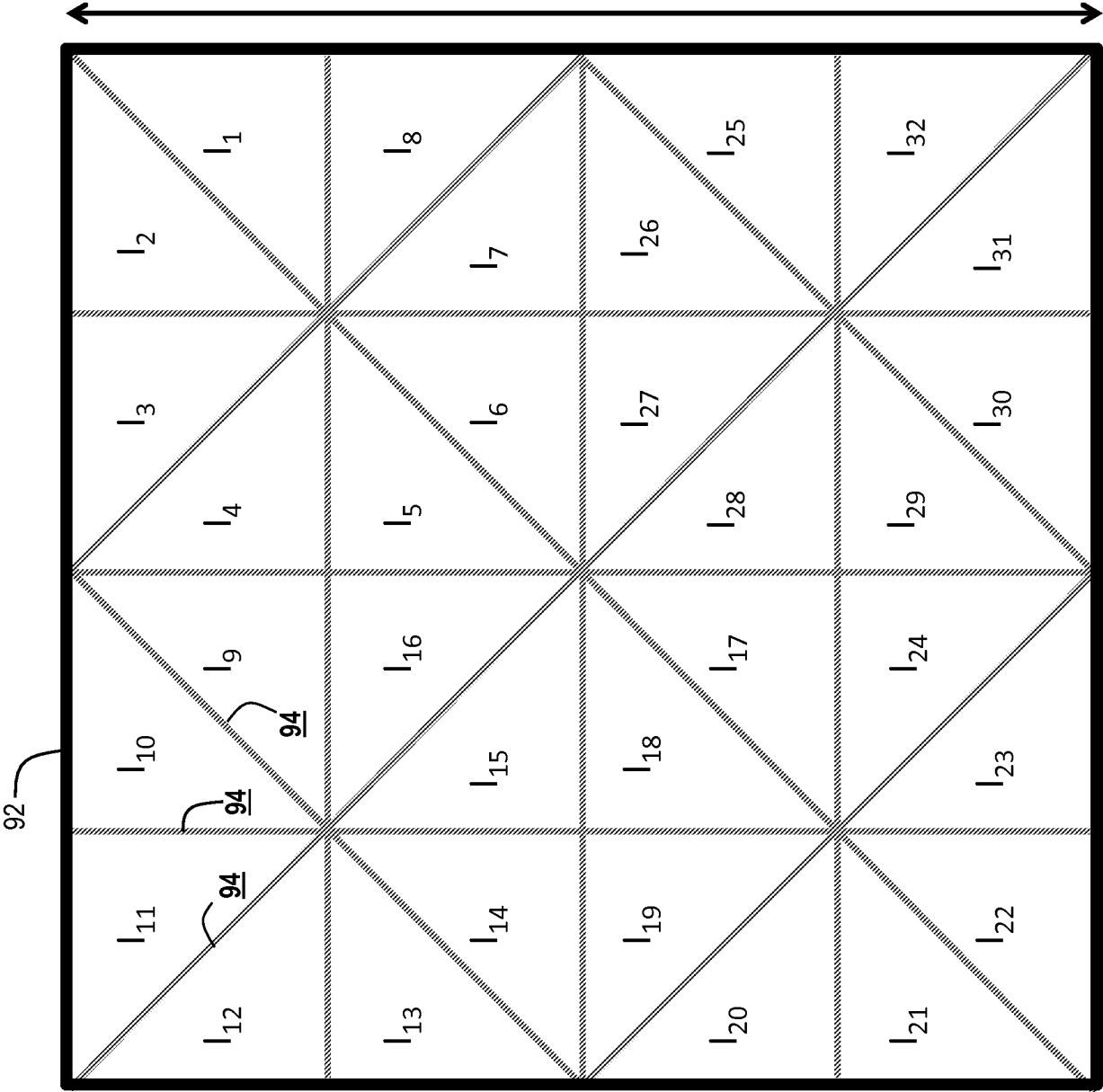


Fig. 7E

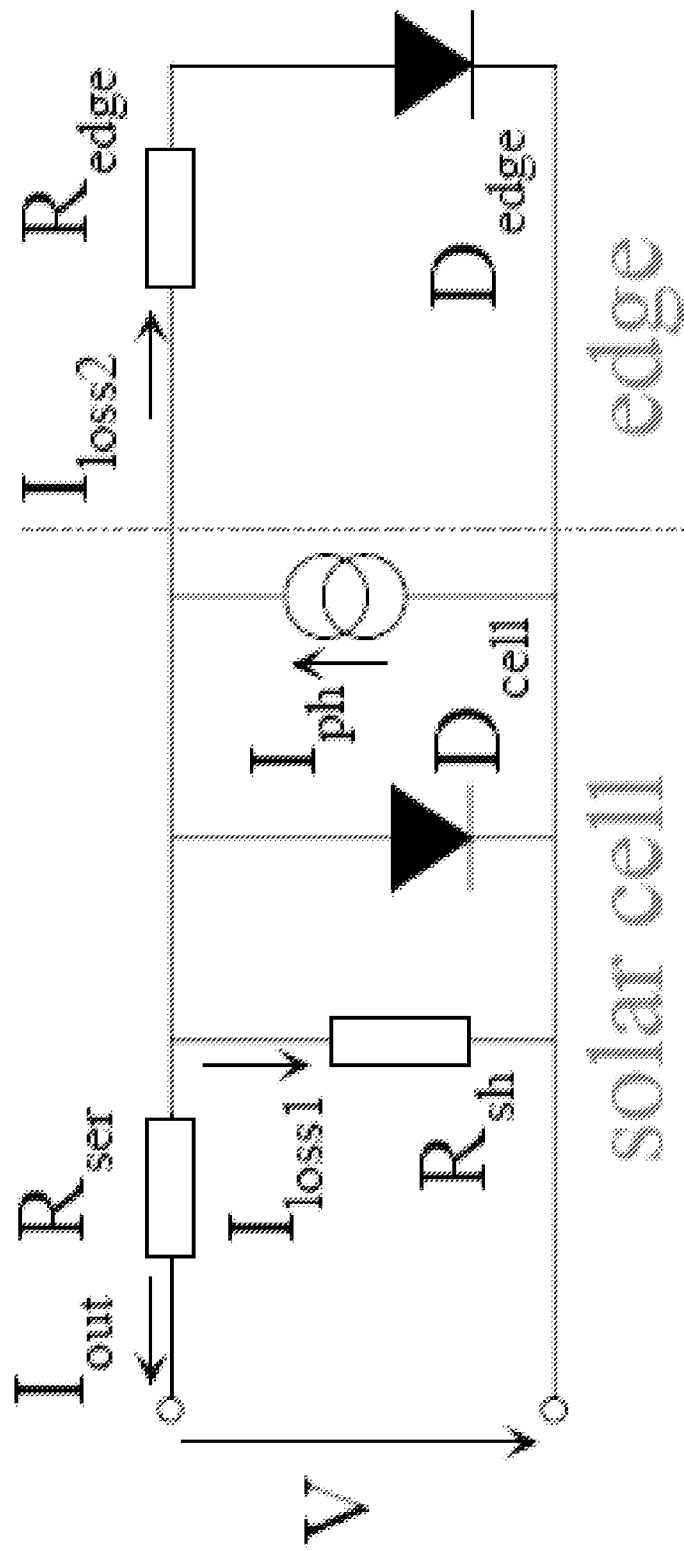


Fig. 8

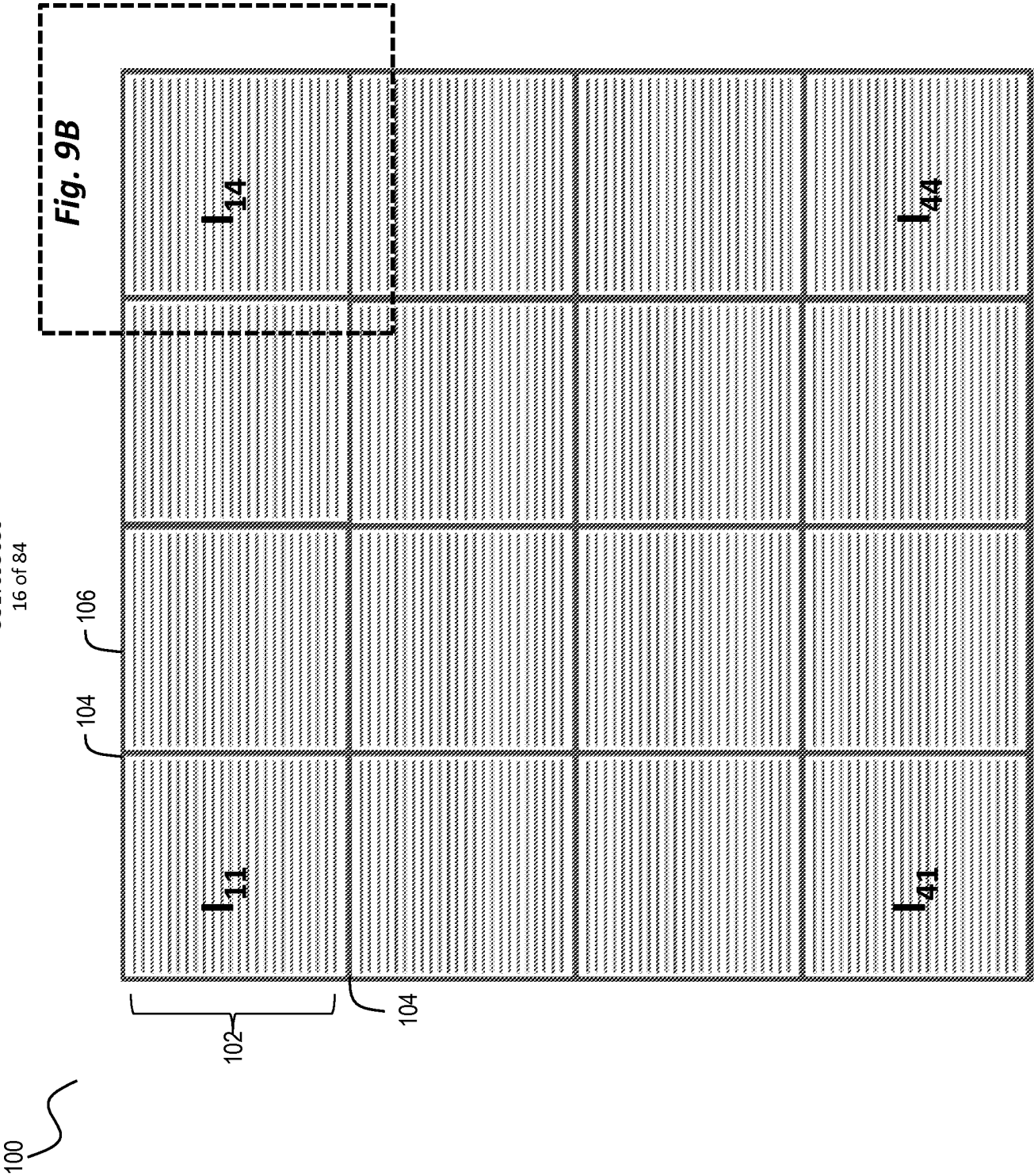


Fig. 9A

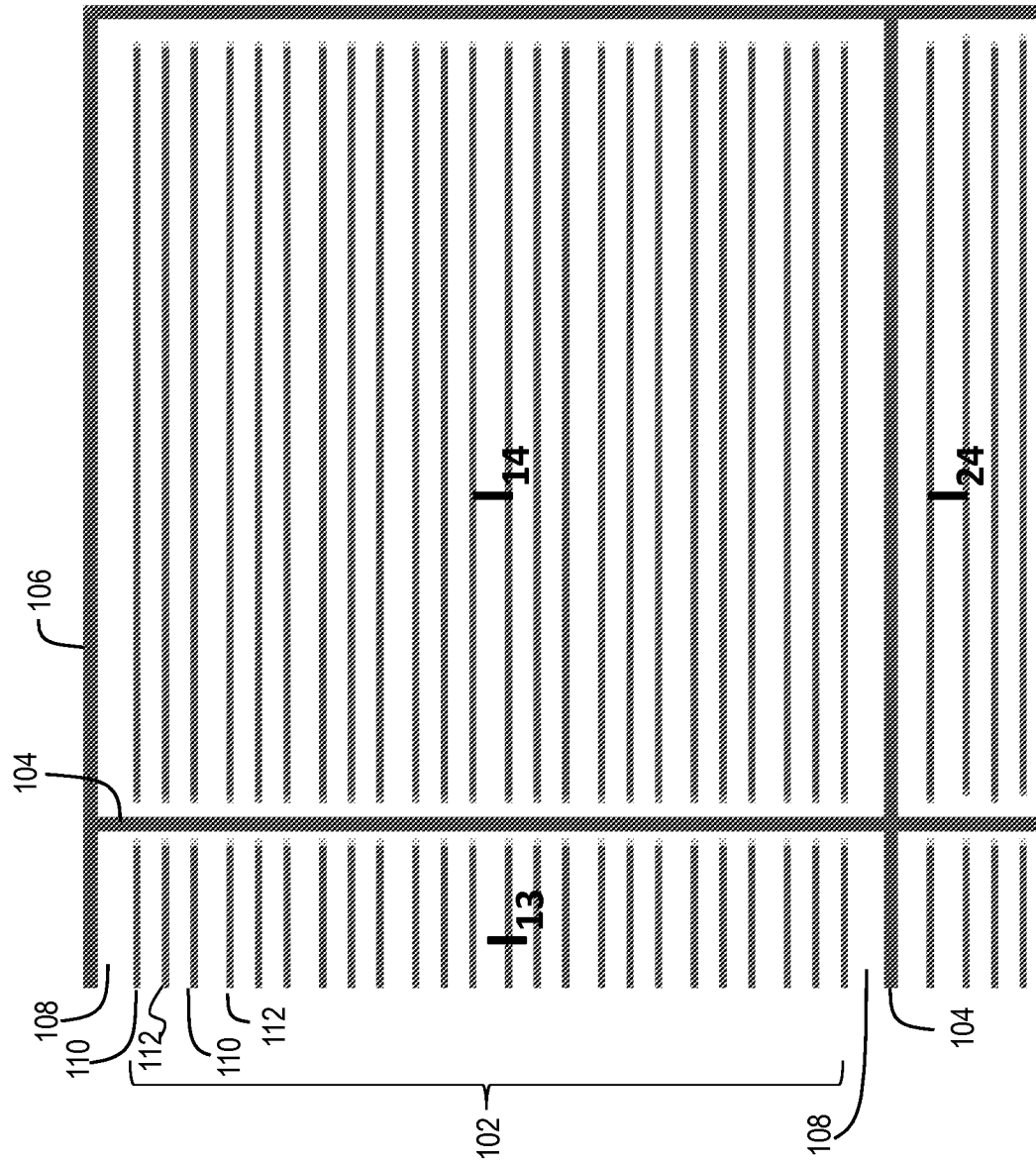


Fig. 9B

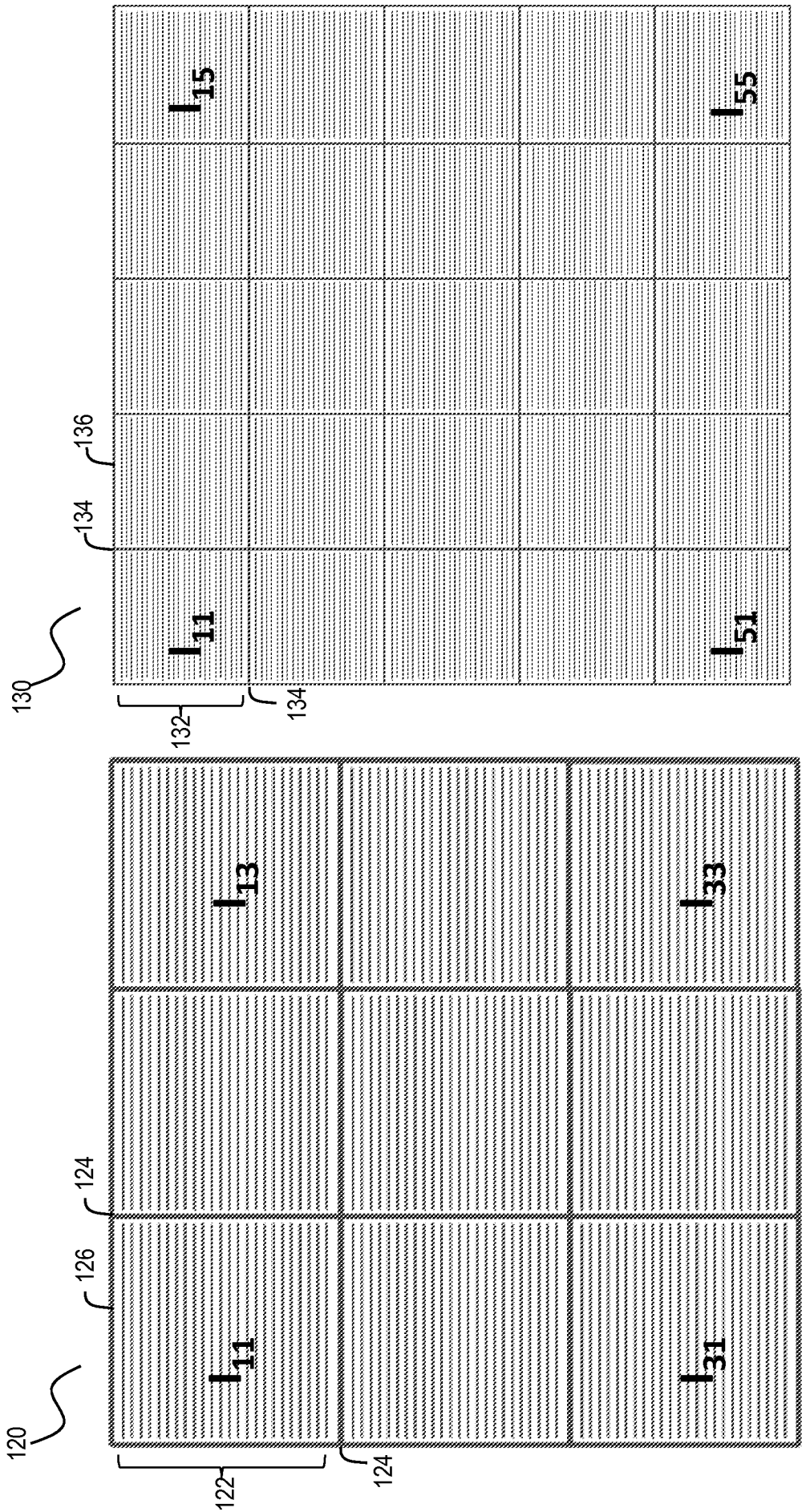


Fig. 10A

Fig. 10B

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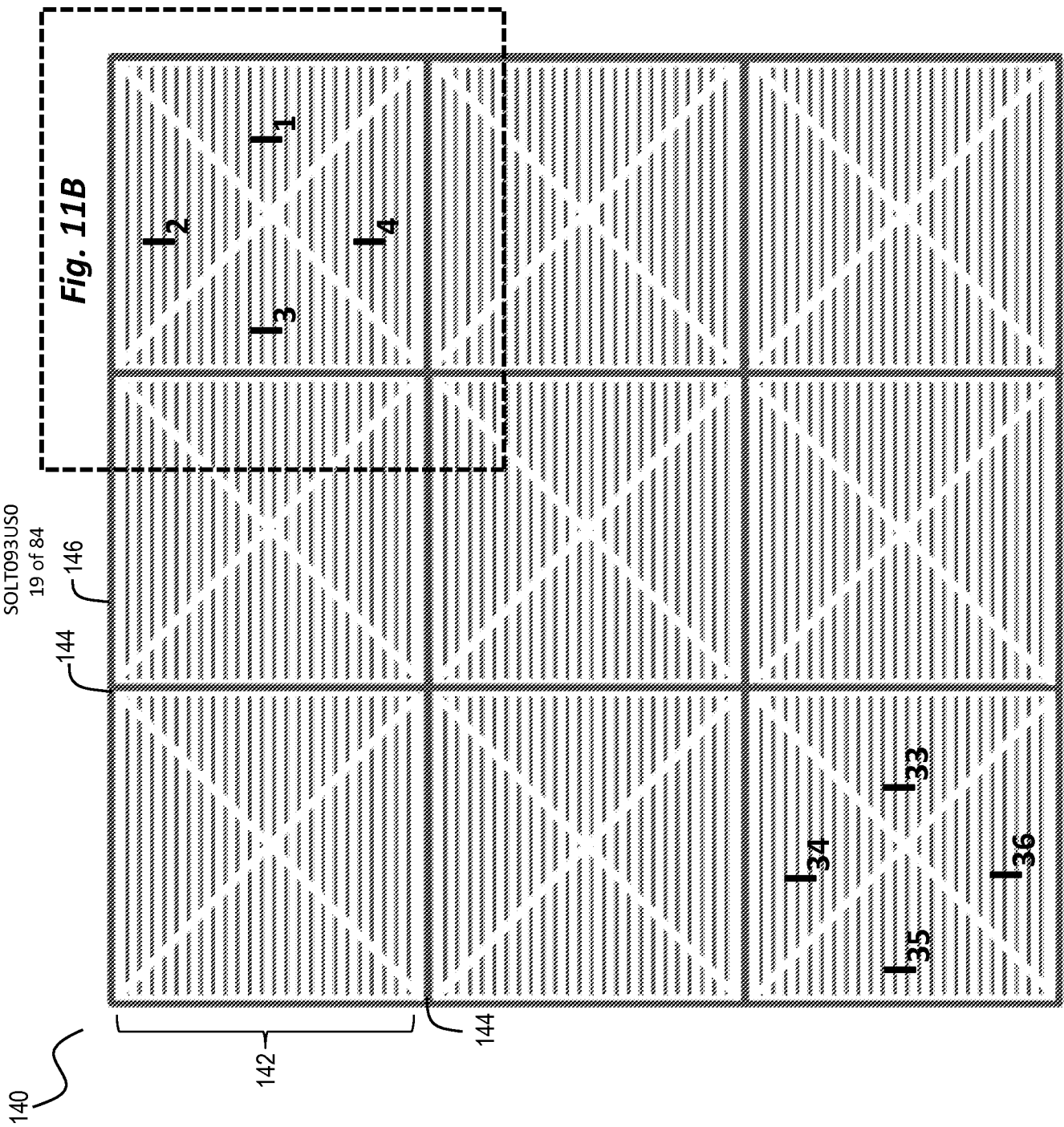


Fig. 11A

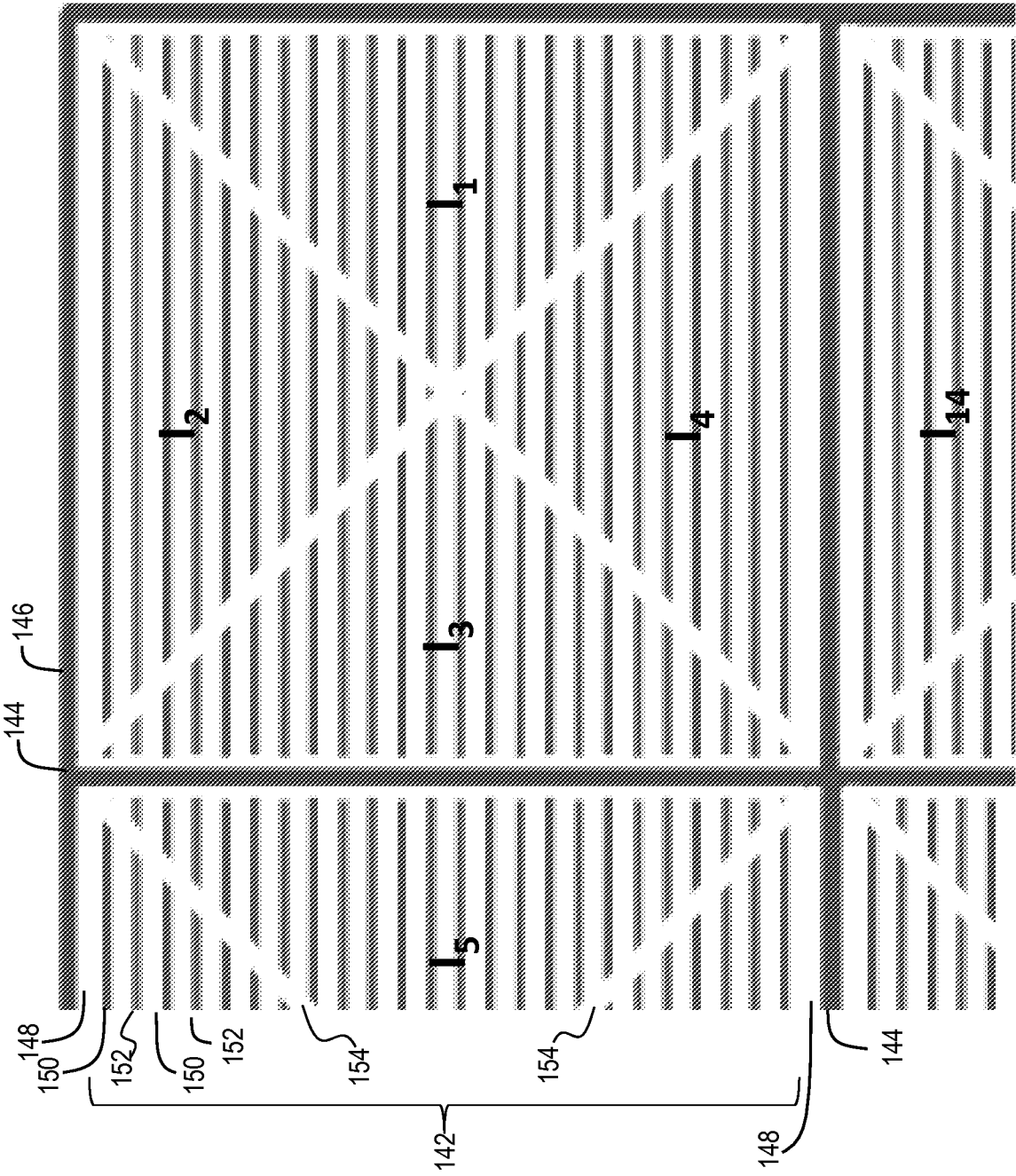


Fig. 11B

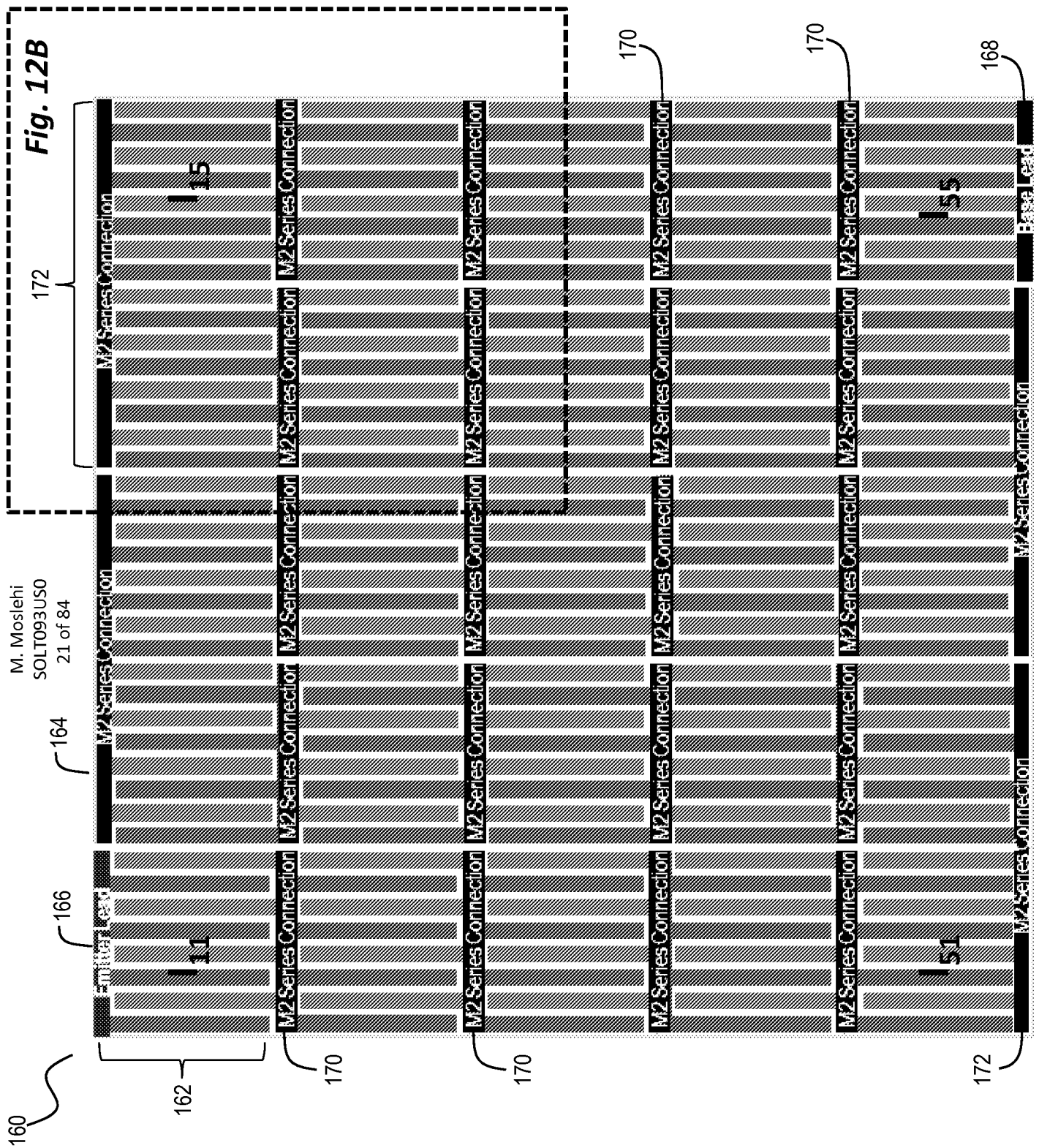


Fig. 12A

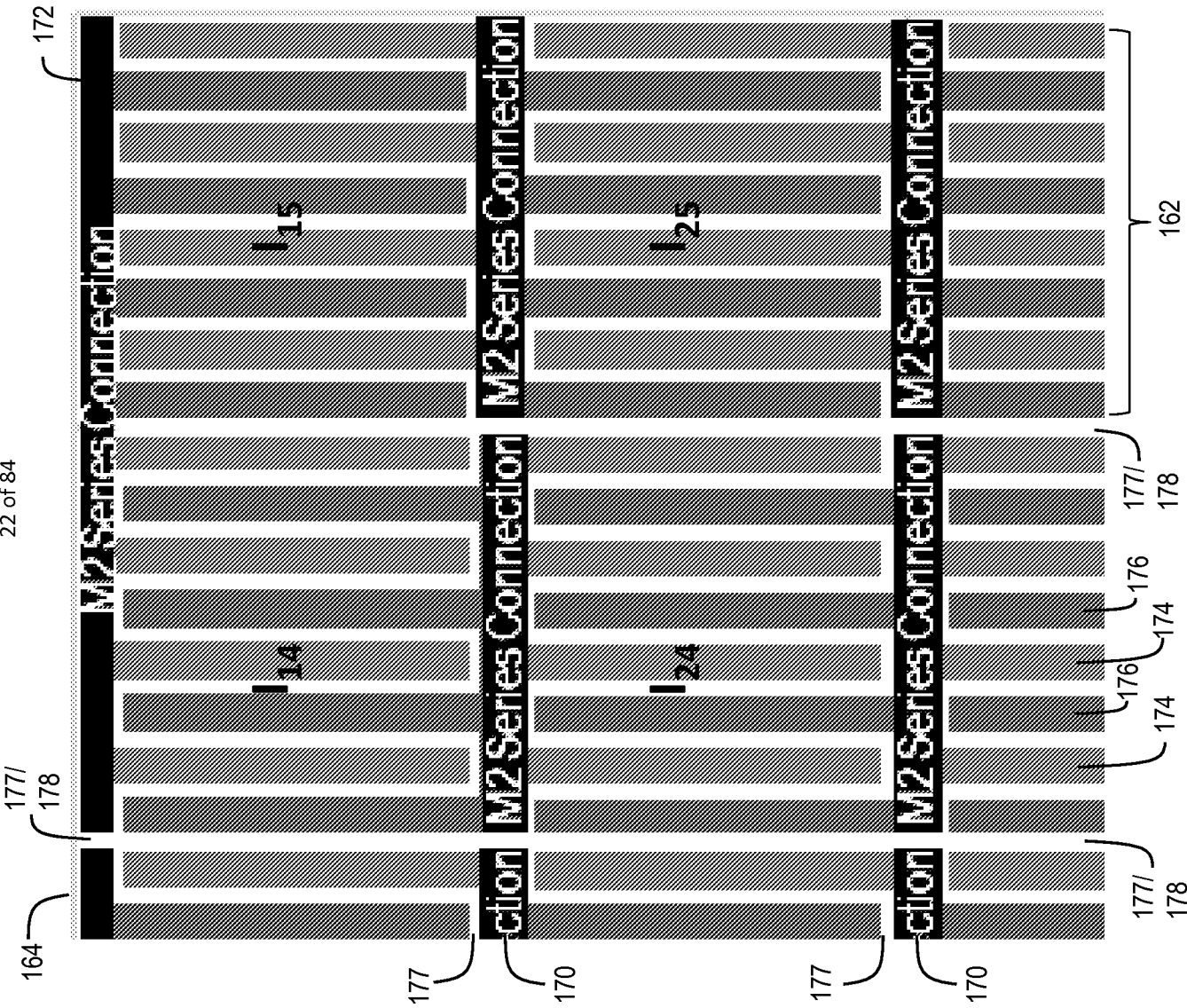


Fig. 12B

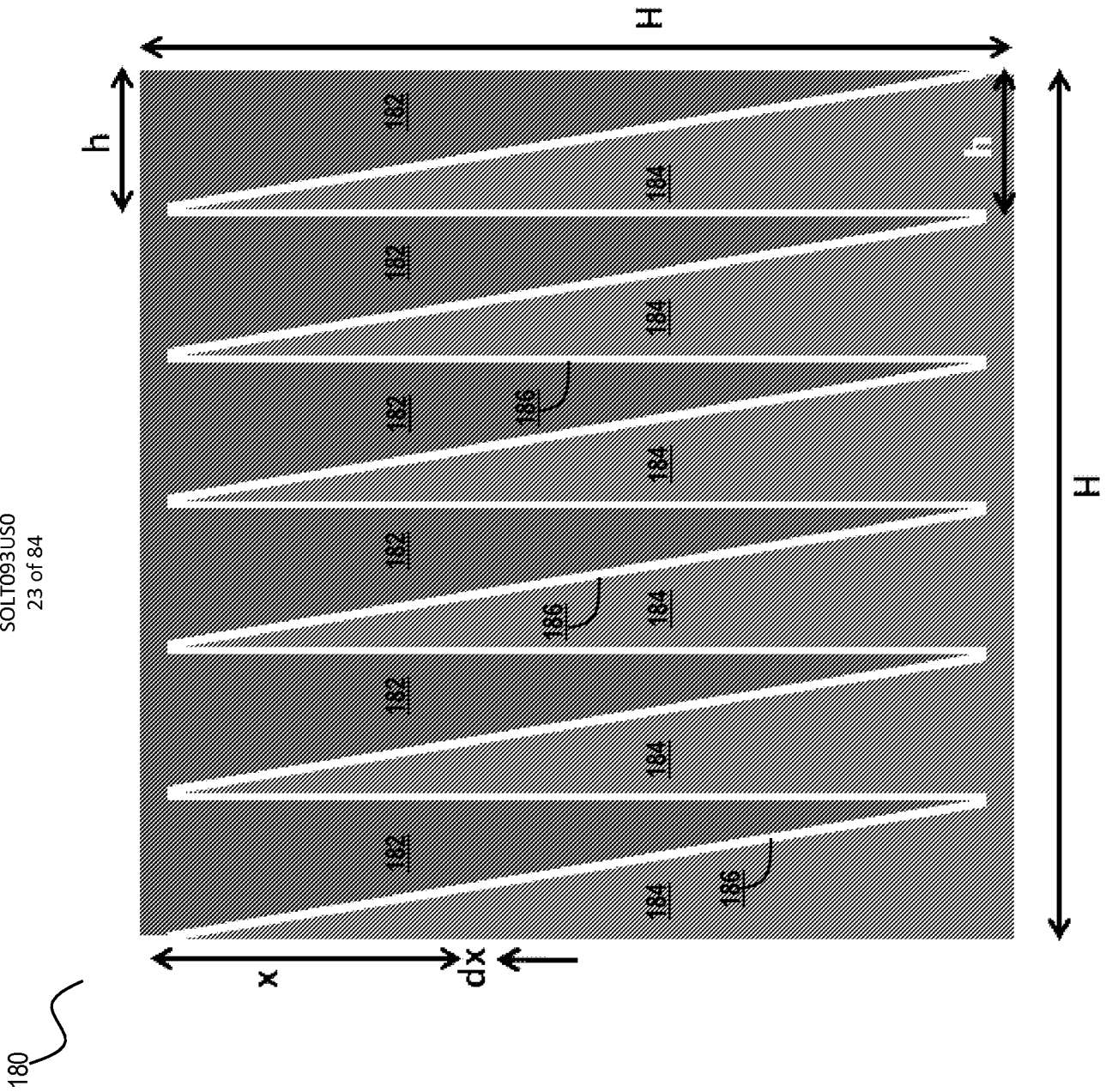


Fig. 13

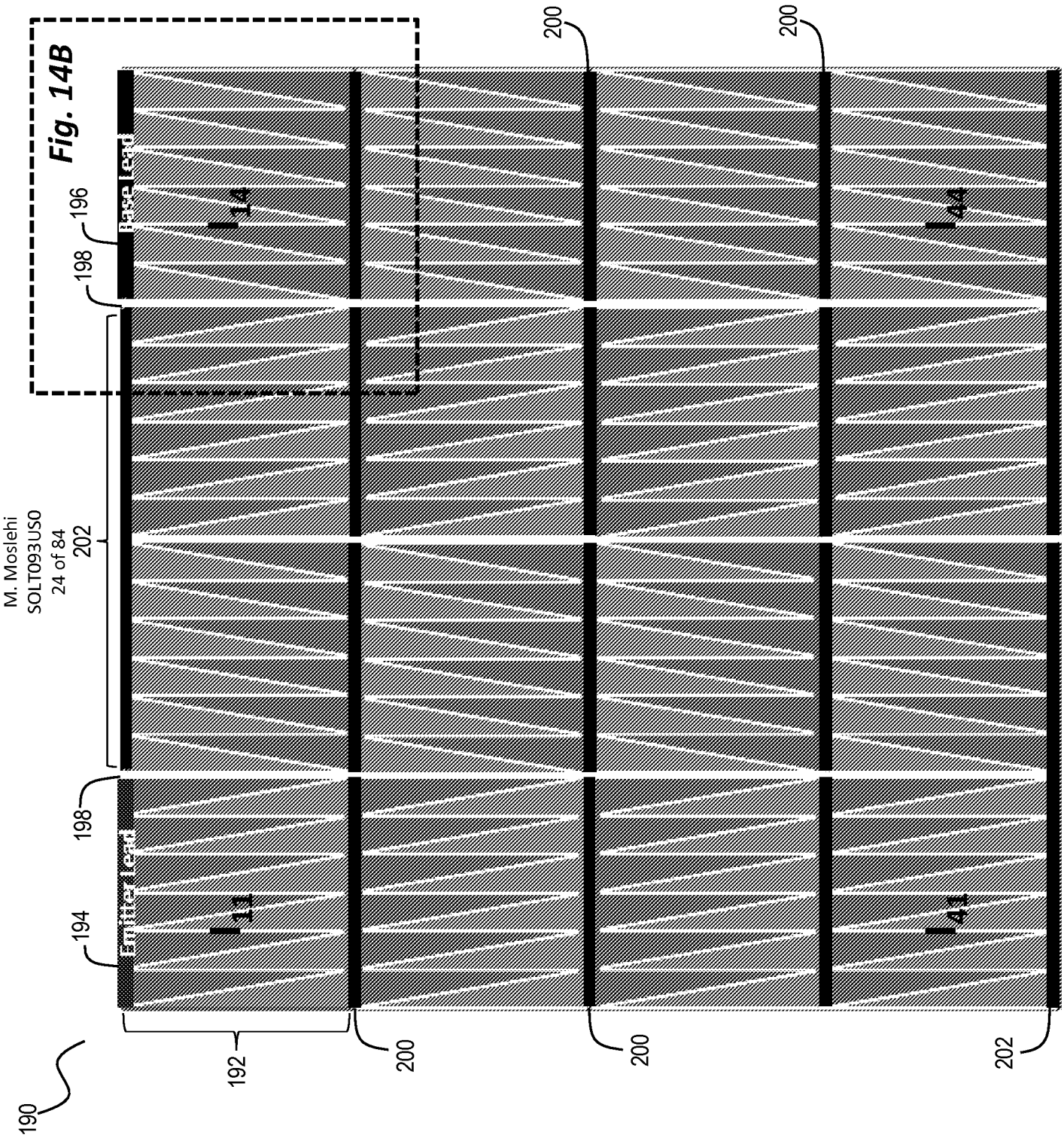


Fig. 14A

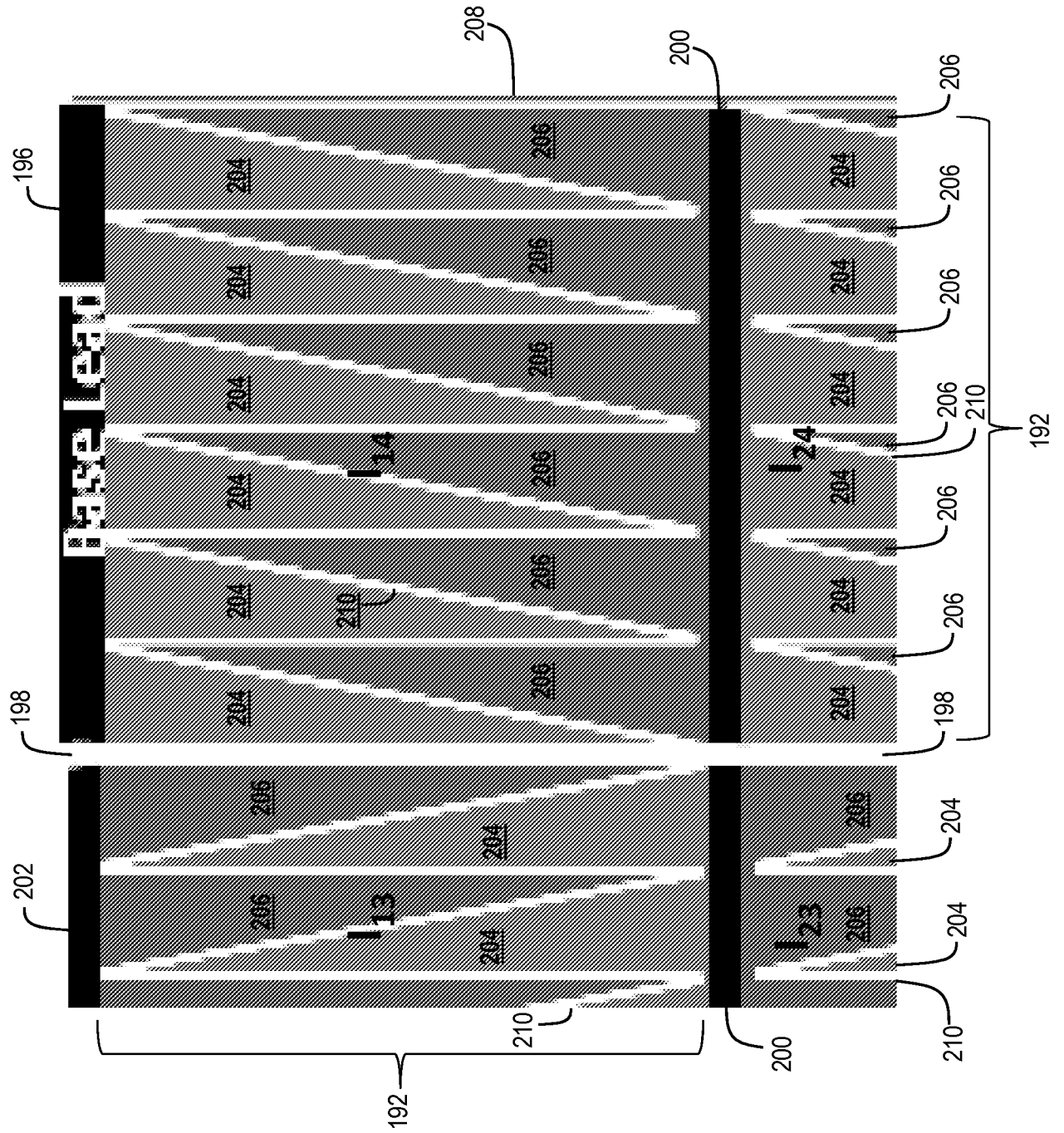


Fig. 14B

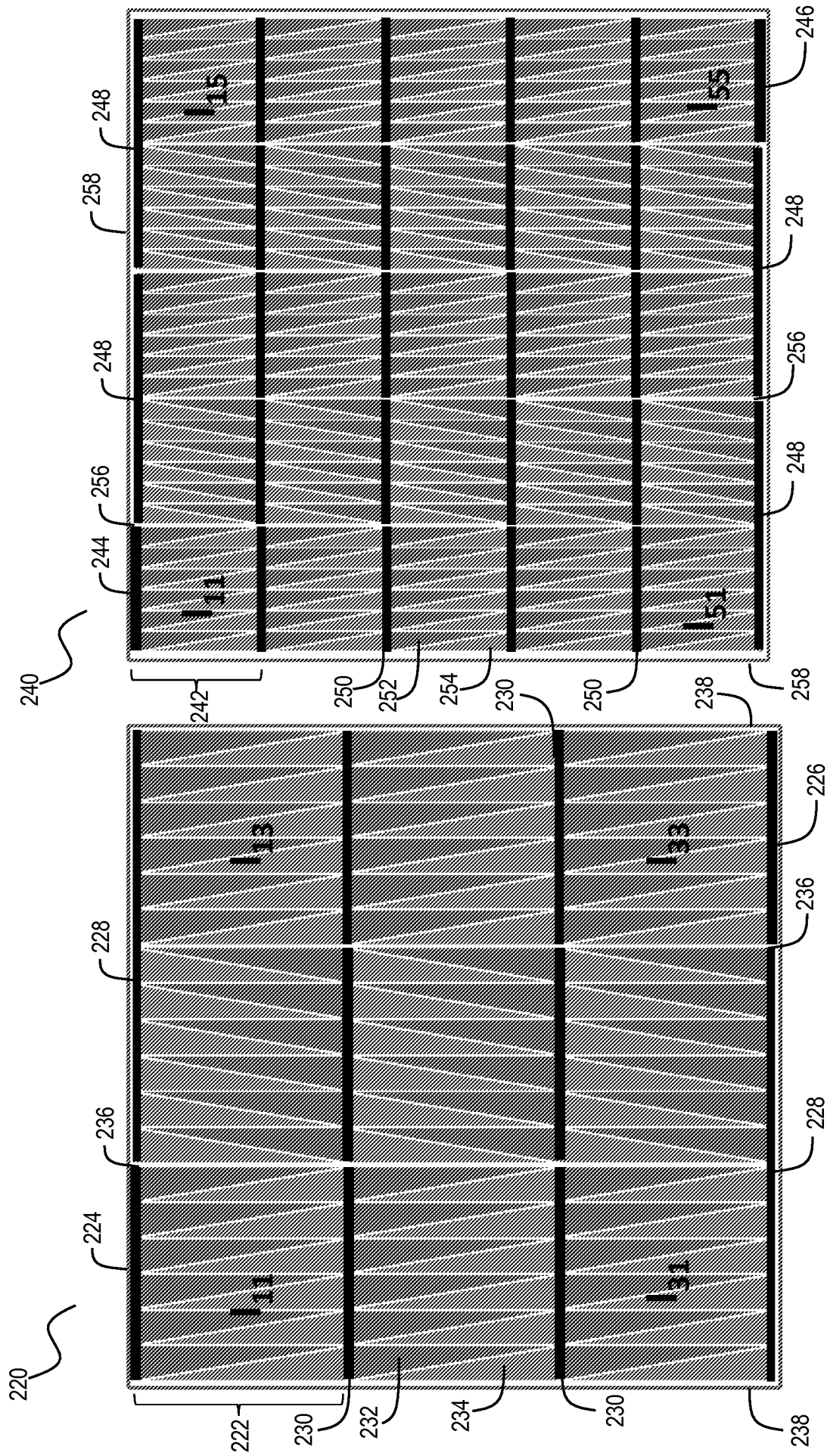


Fig. 15B

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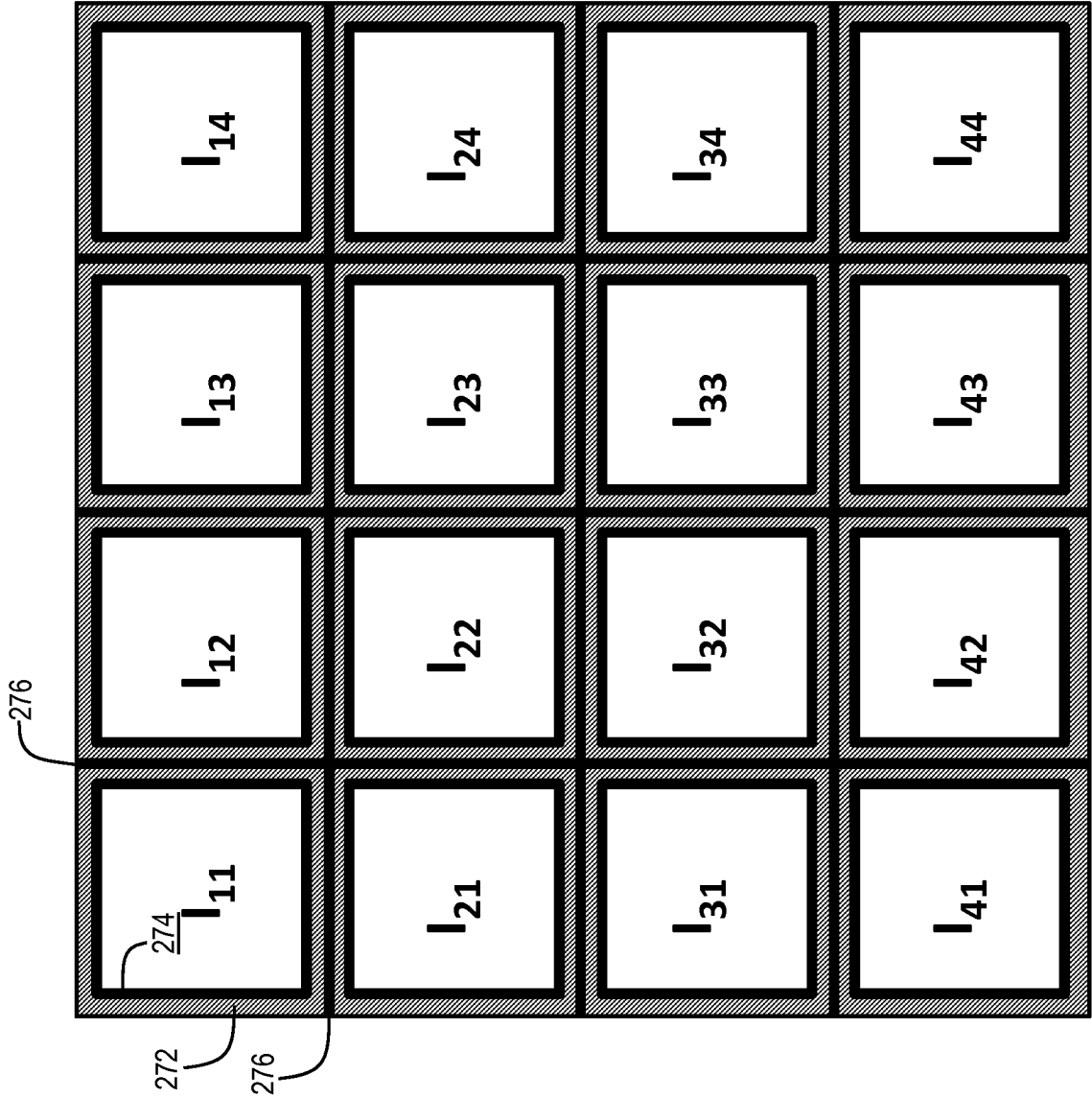


Fig. 16A

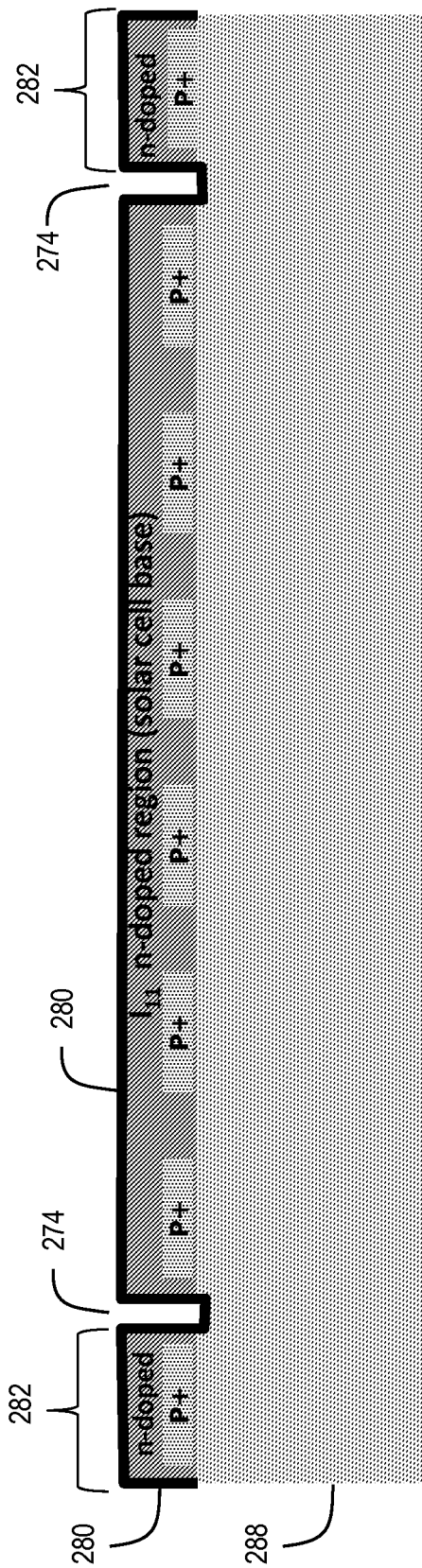


Fig. 16B

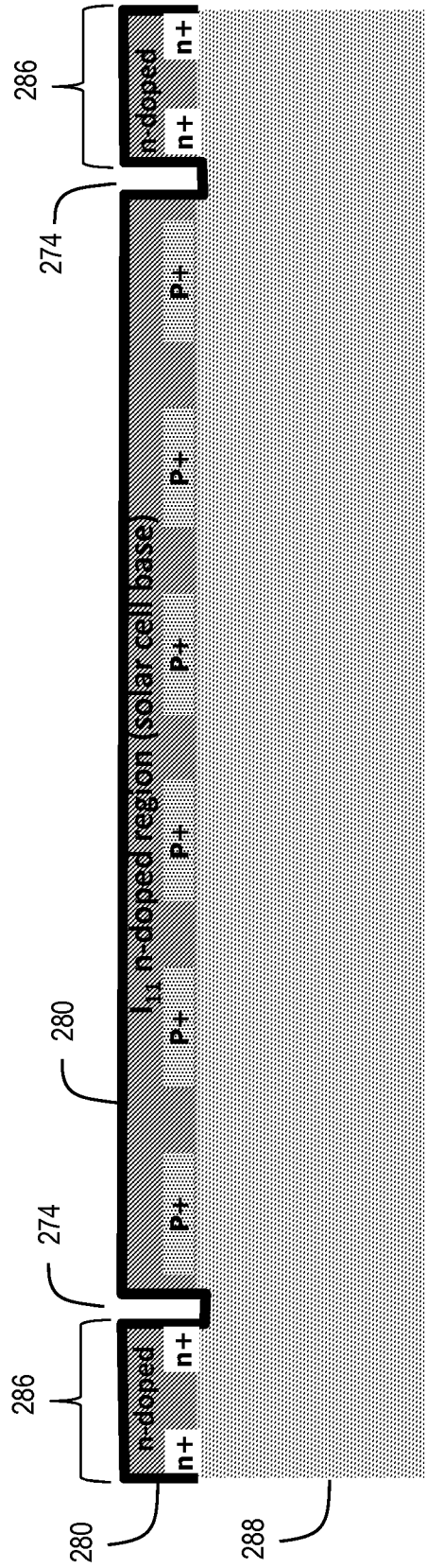


Fig. 16C

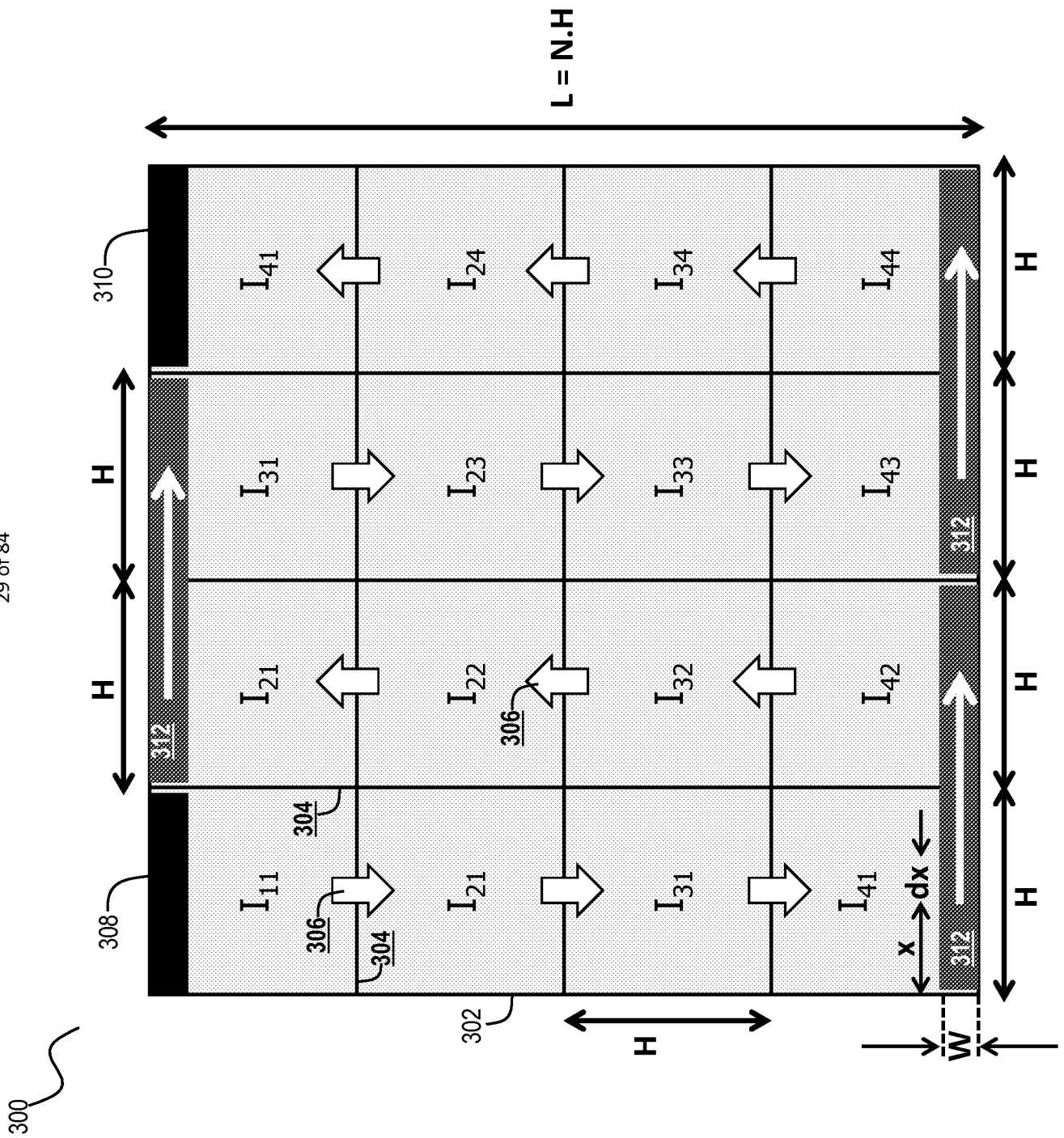
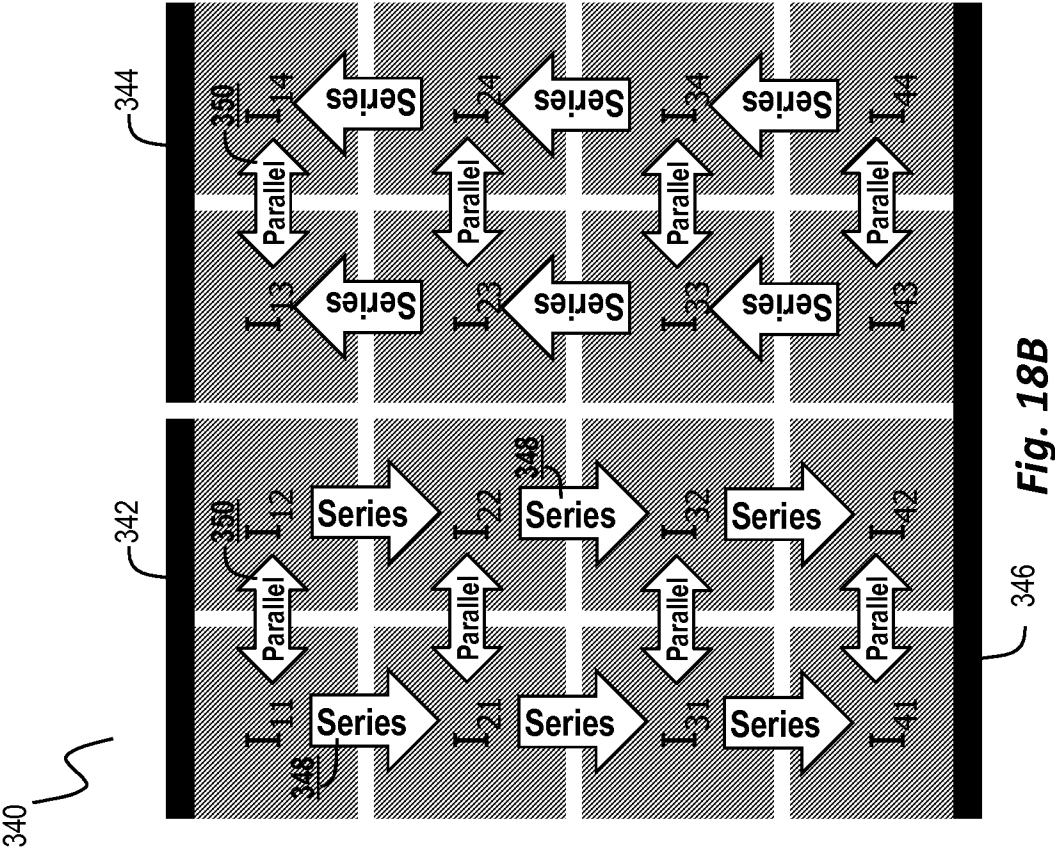
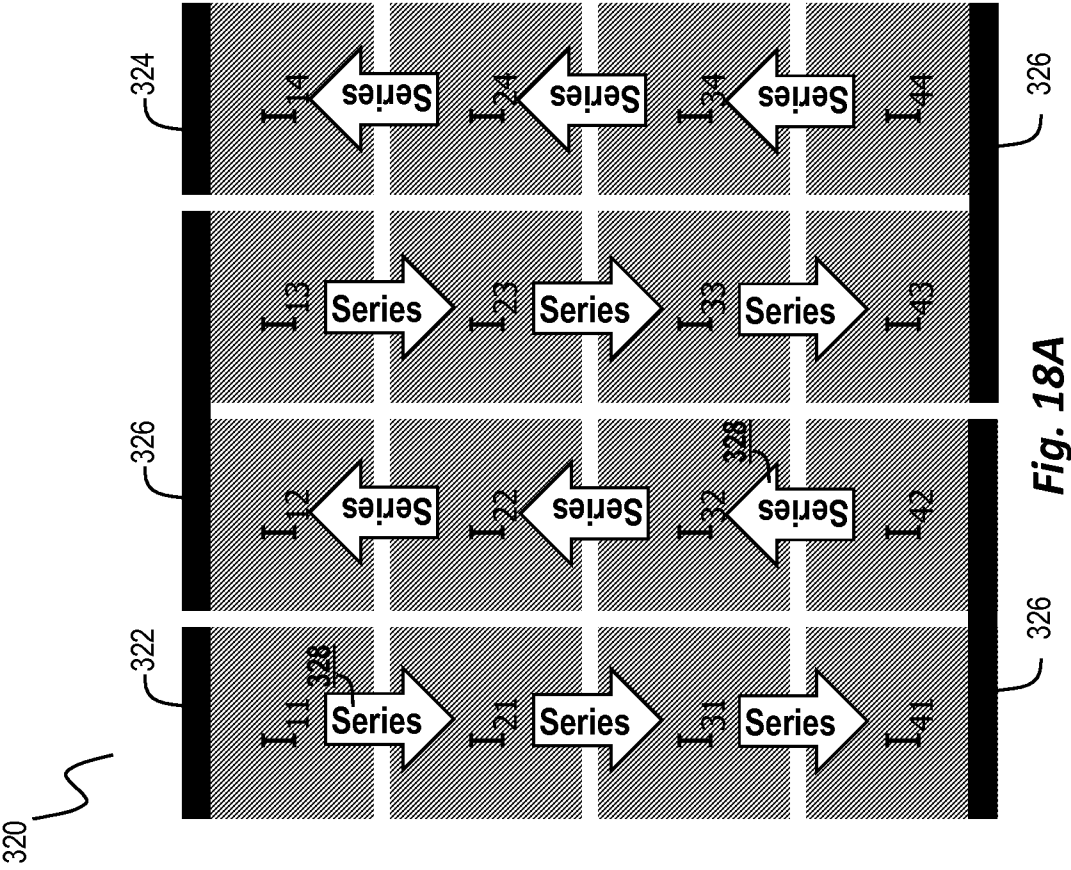


Fig. 17



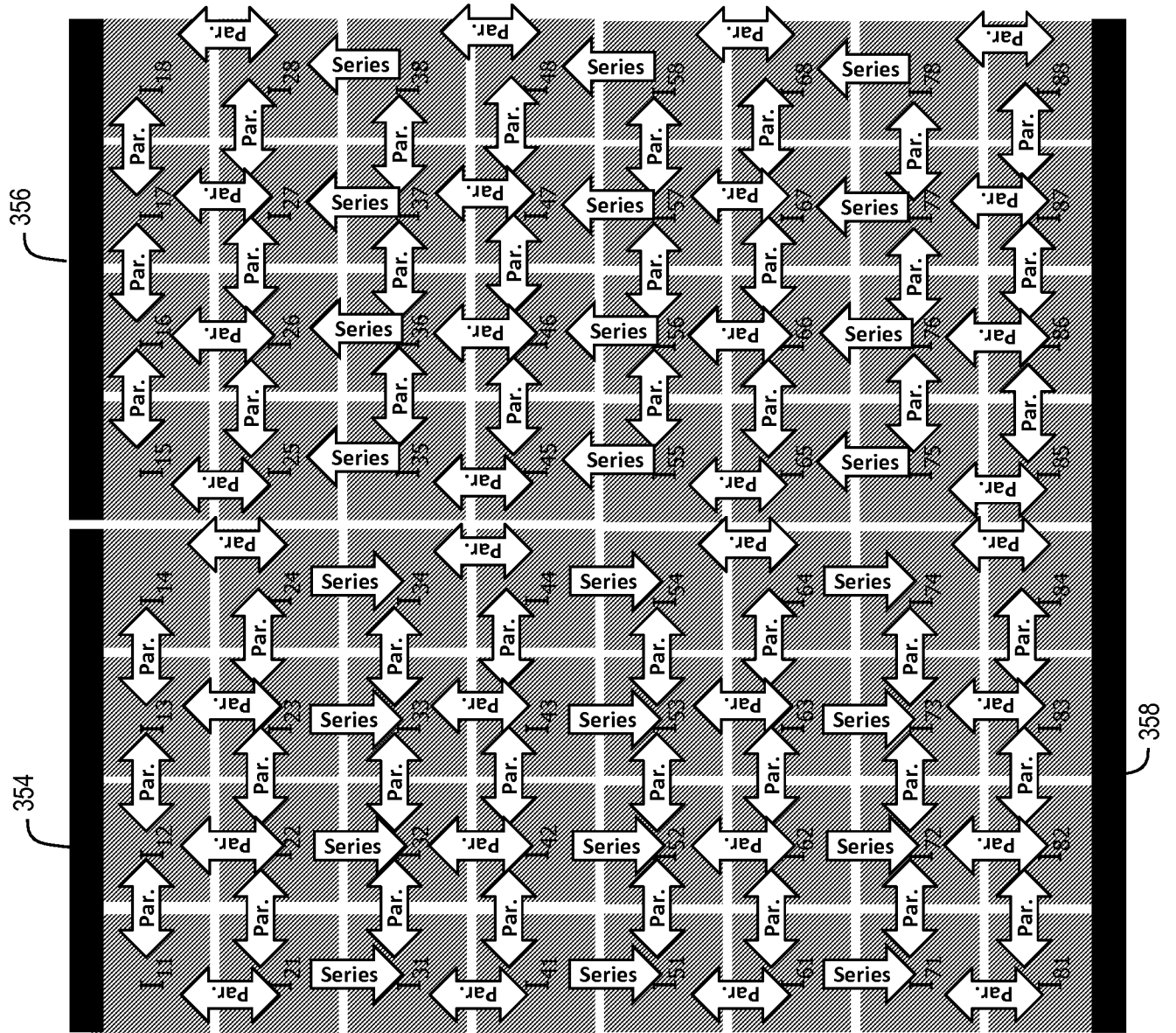
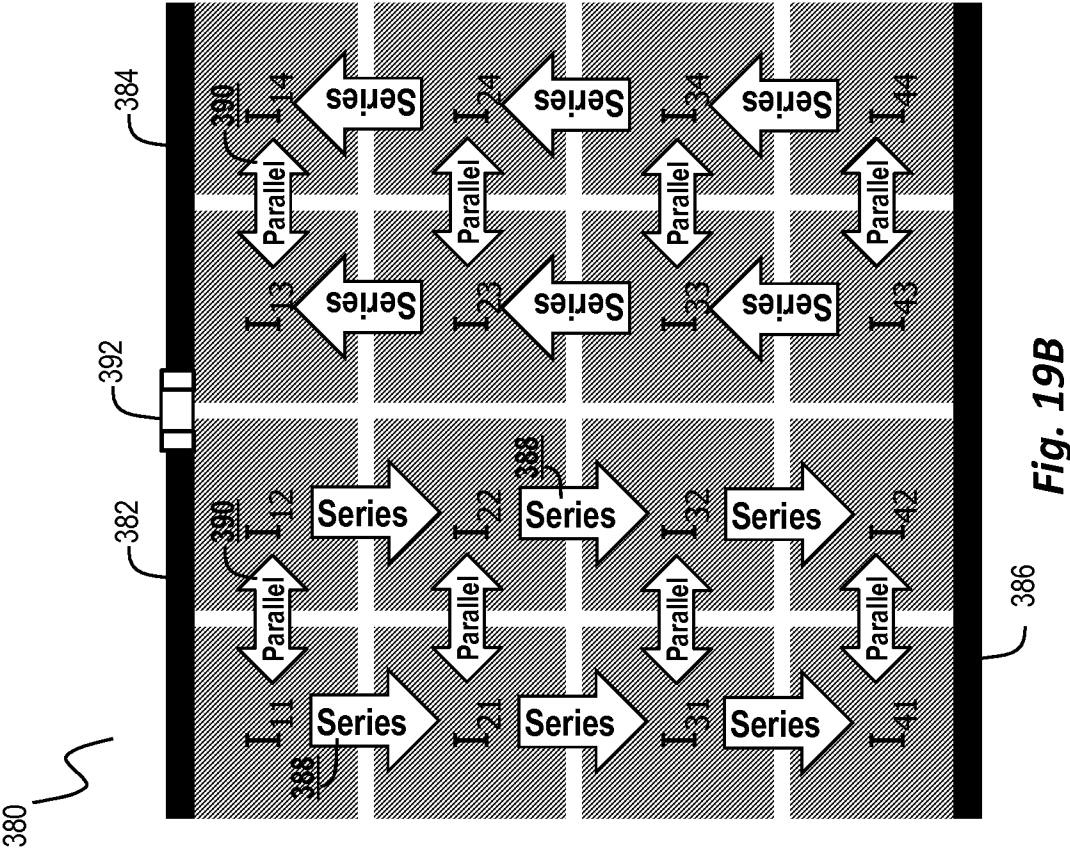
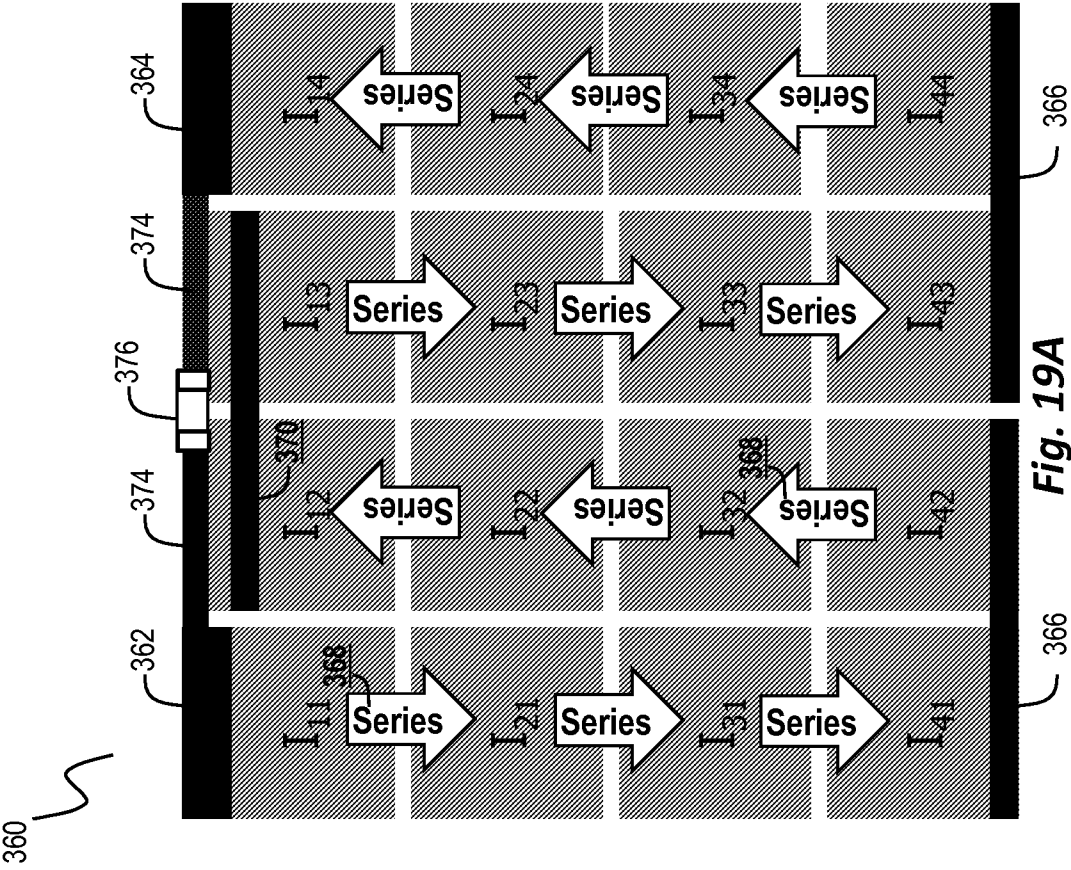


Fig. 18C



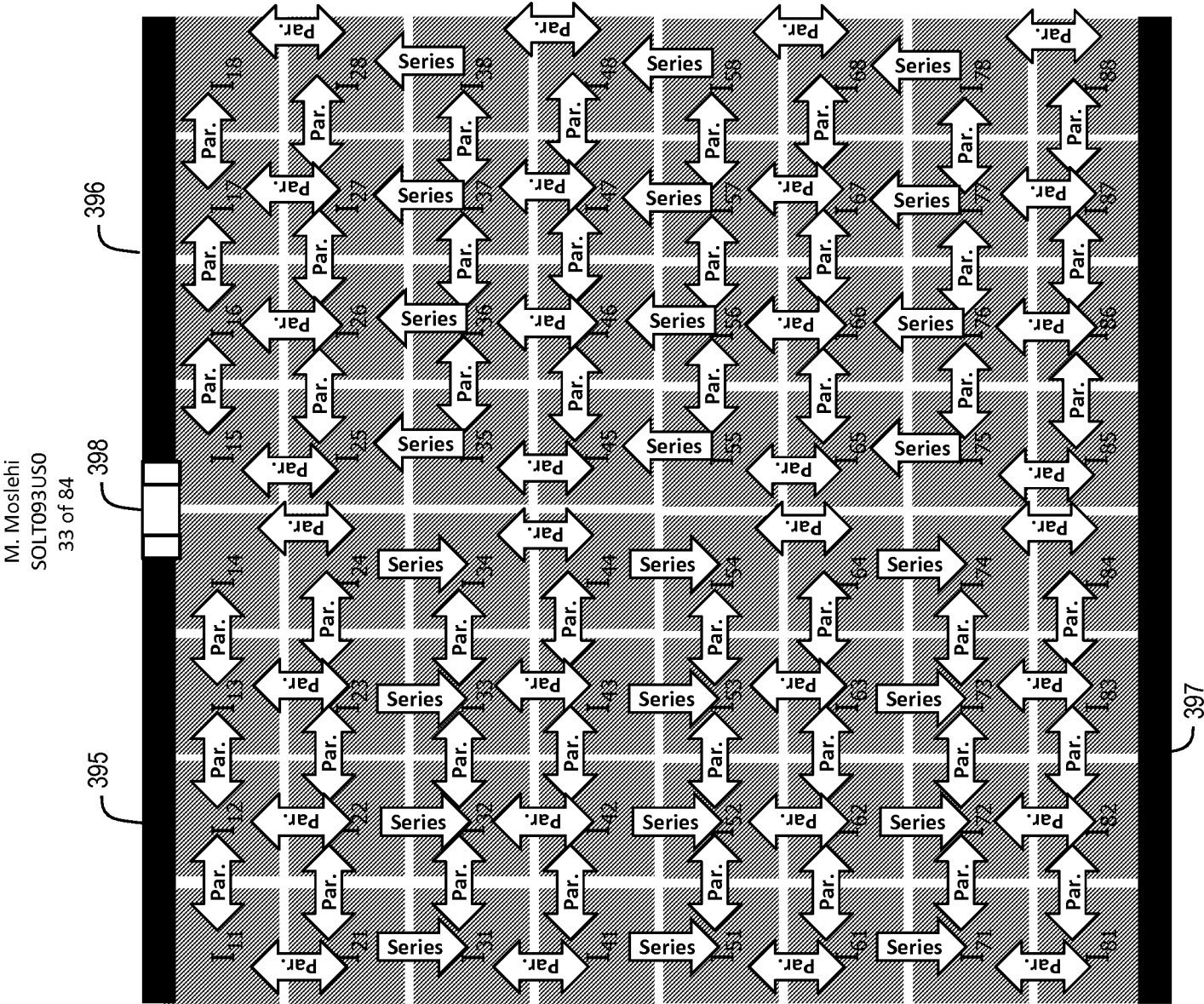


Fig. 19C

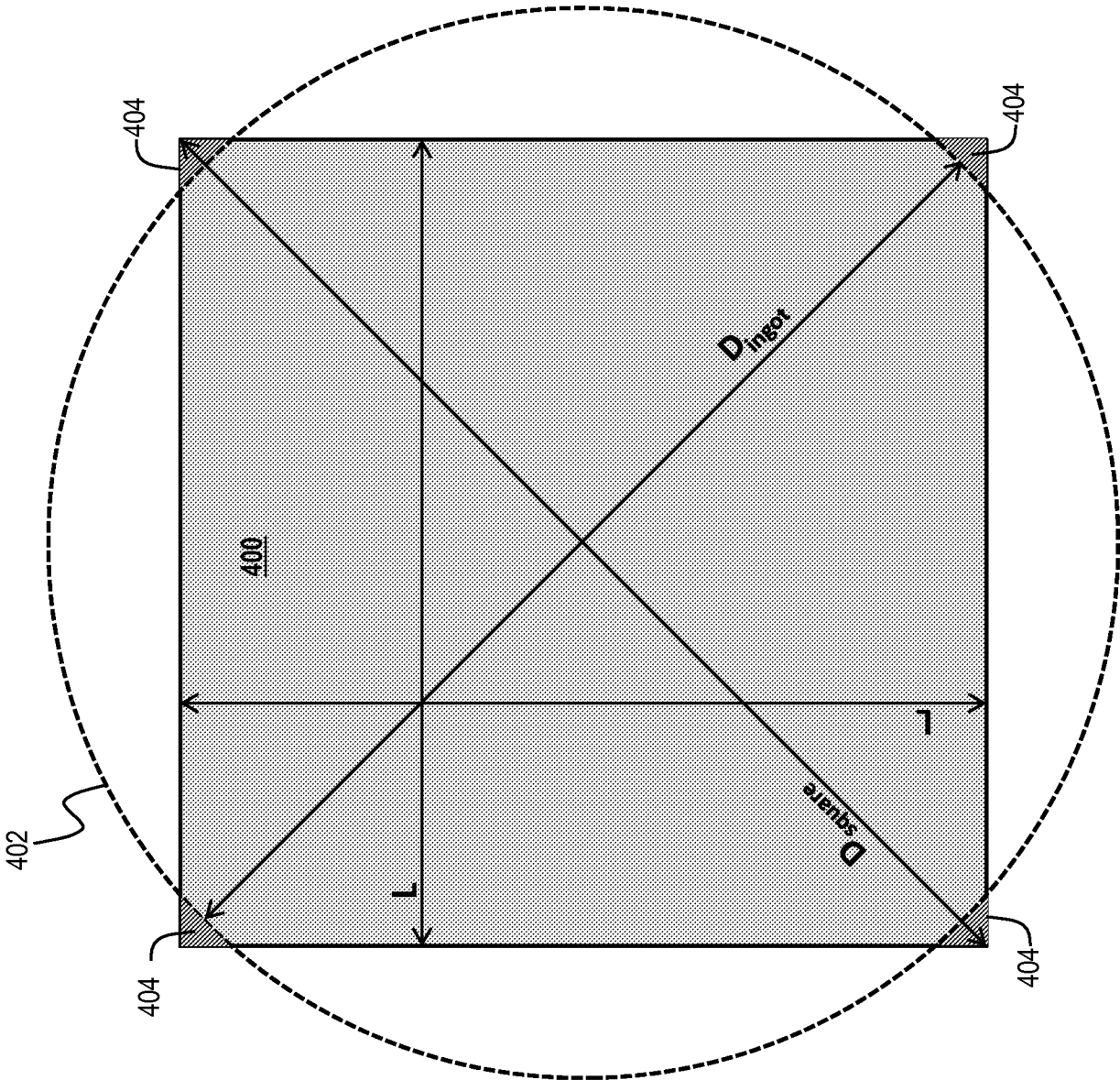


Fig. 20

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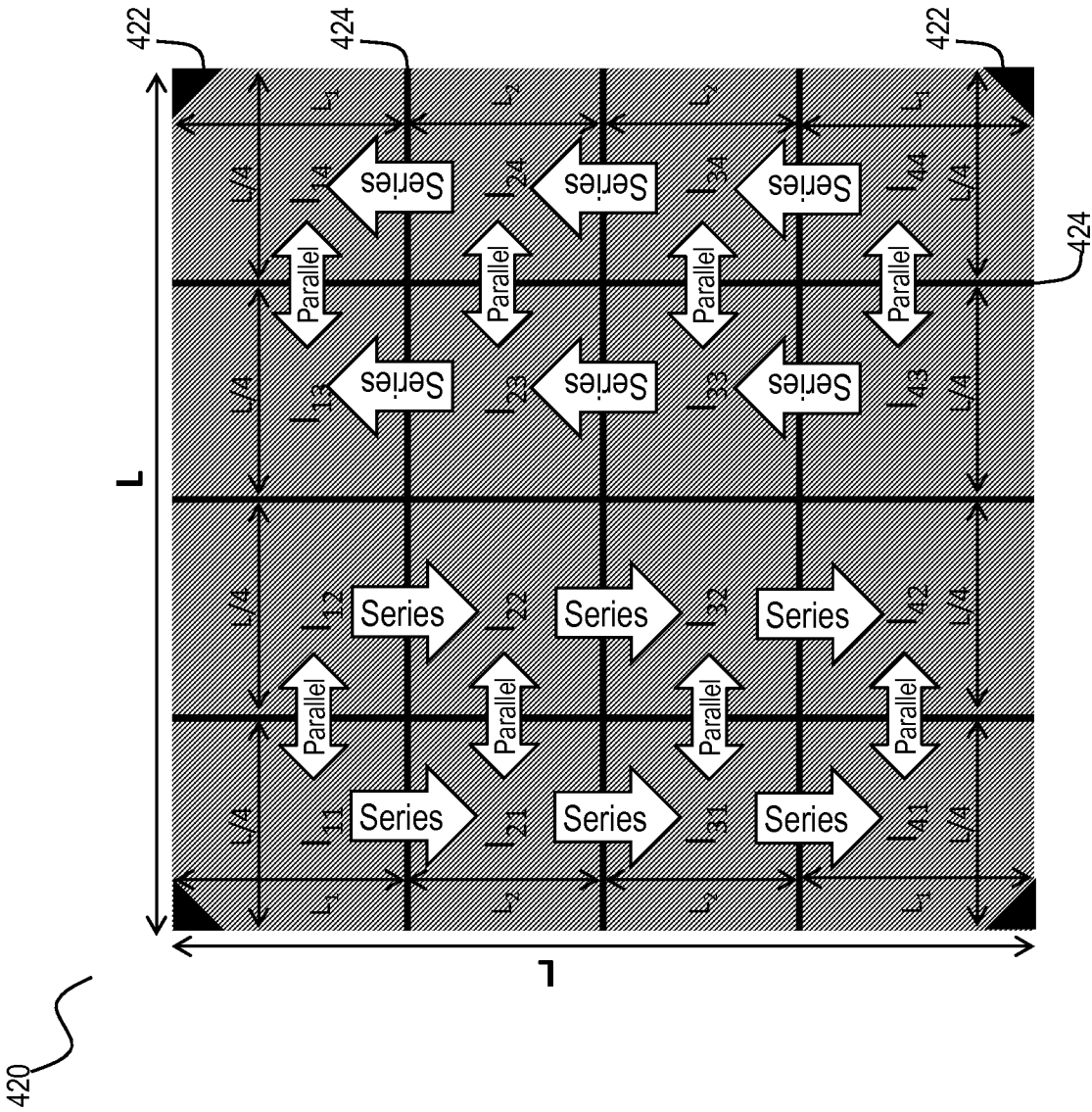


Fig. 21

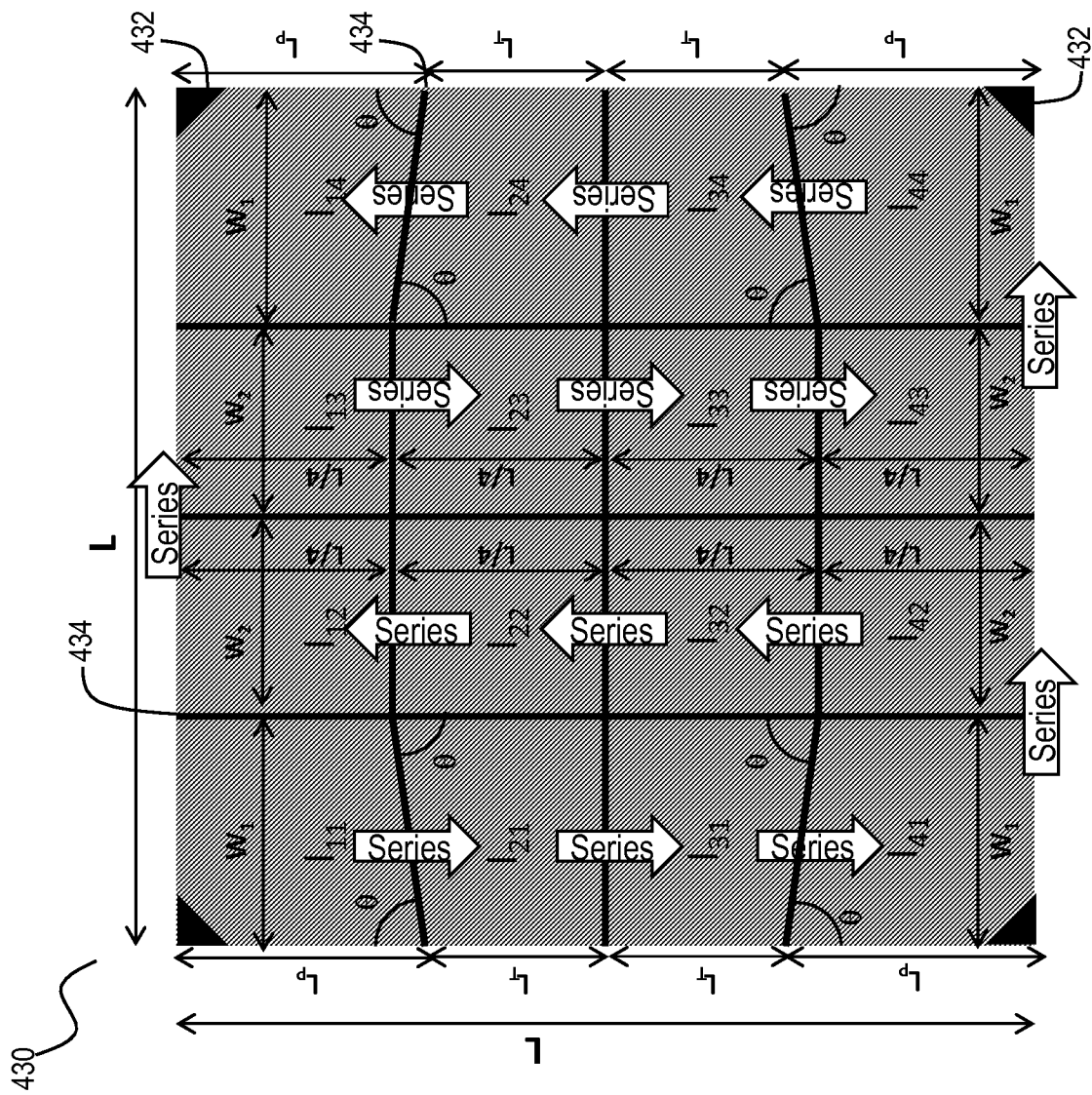


Fig. 22

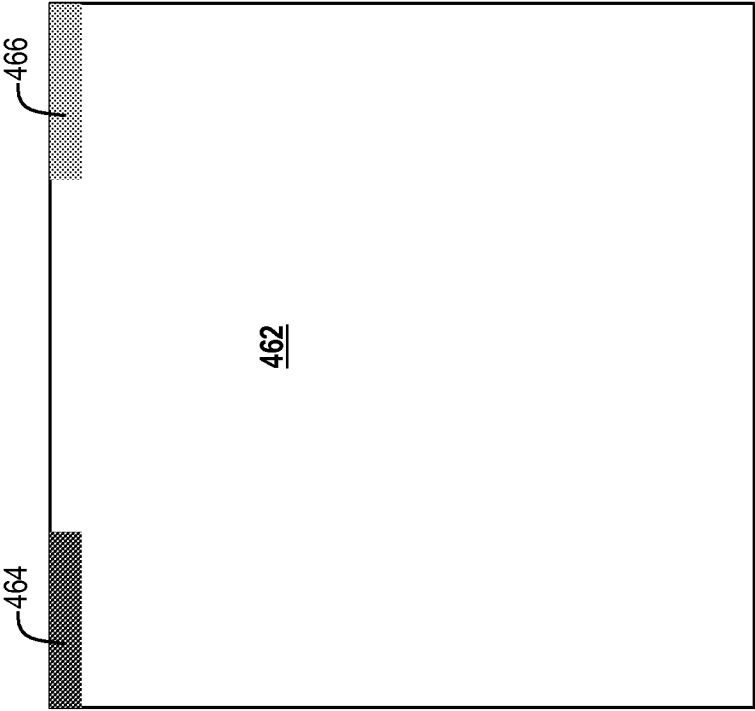


Fig. 23B

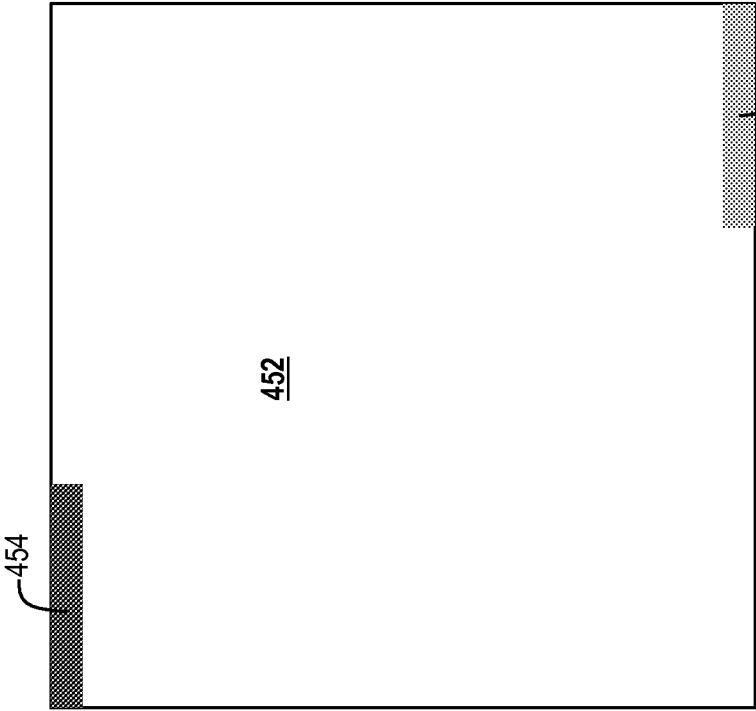


Fig. 23A

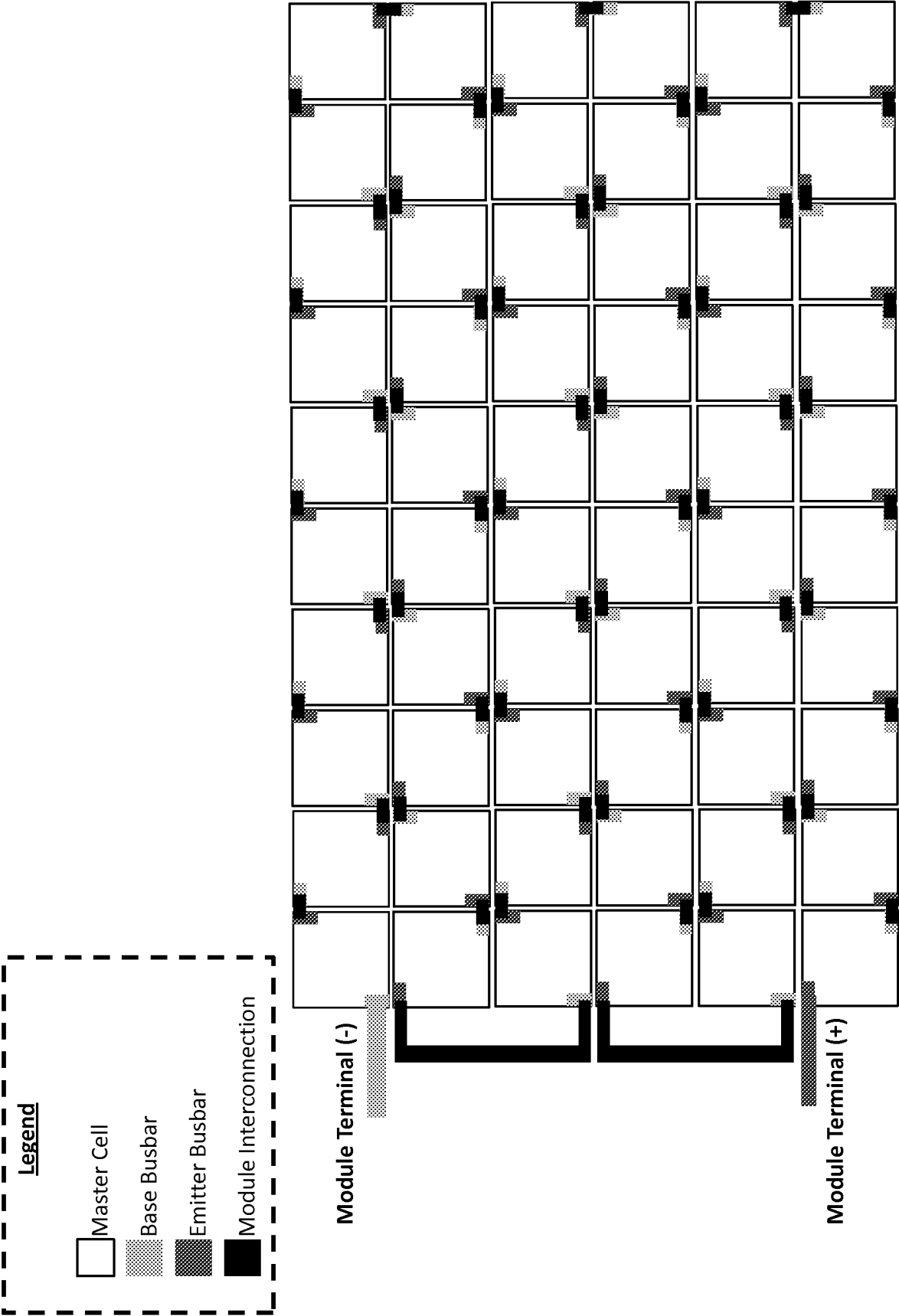


Fig. 24

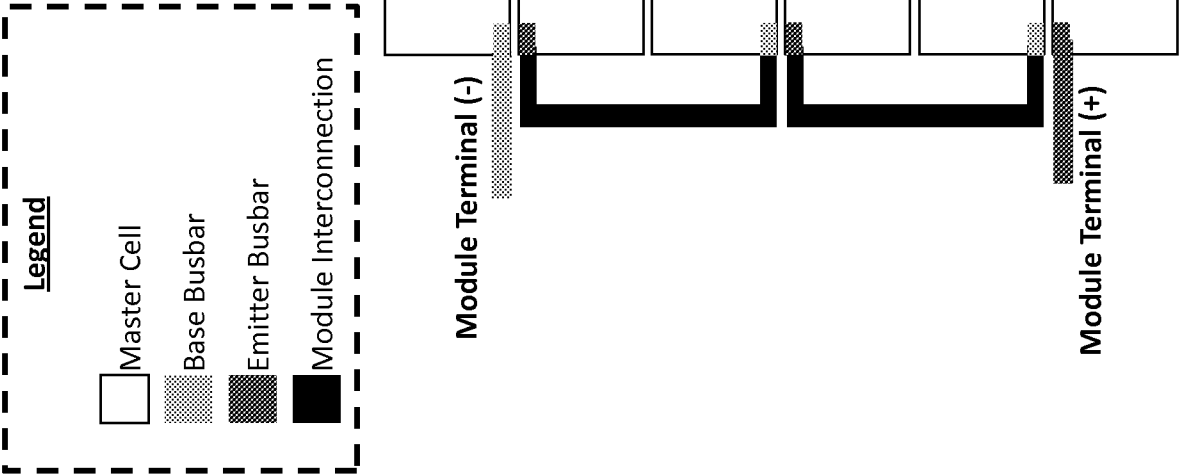


Fig. 25

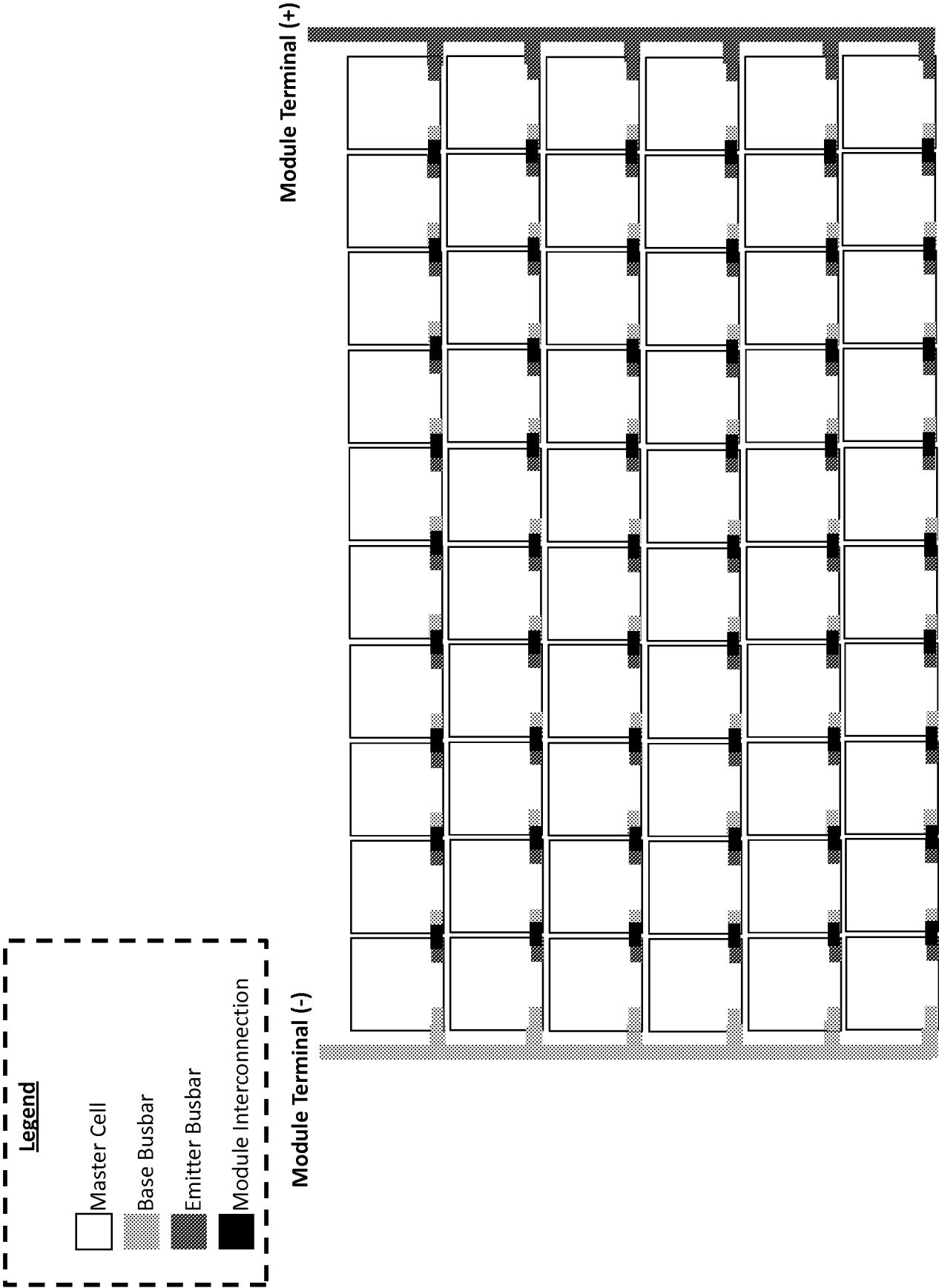


Fig. 26

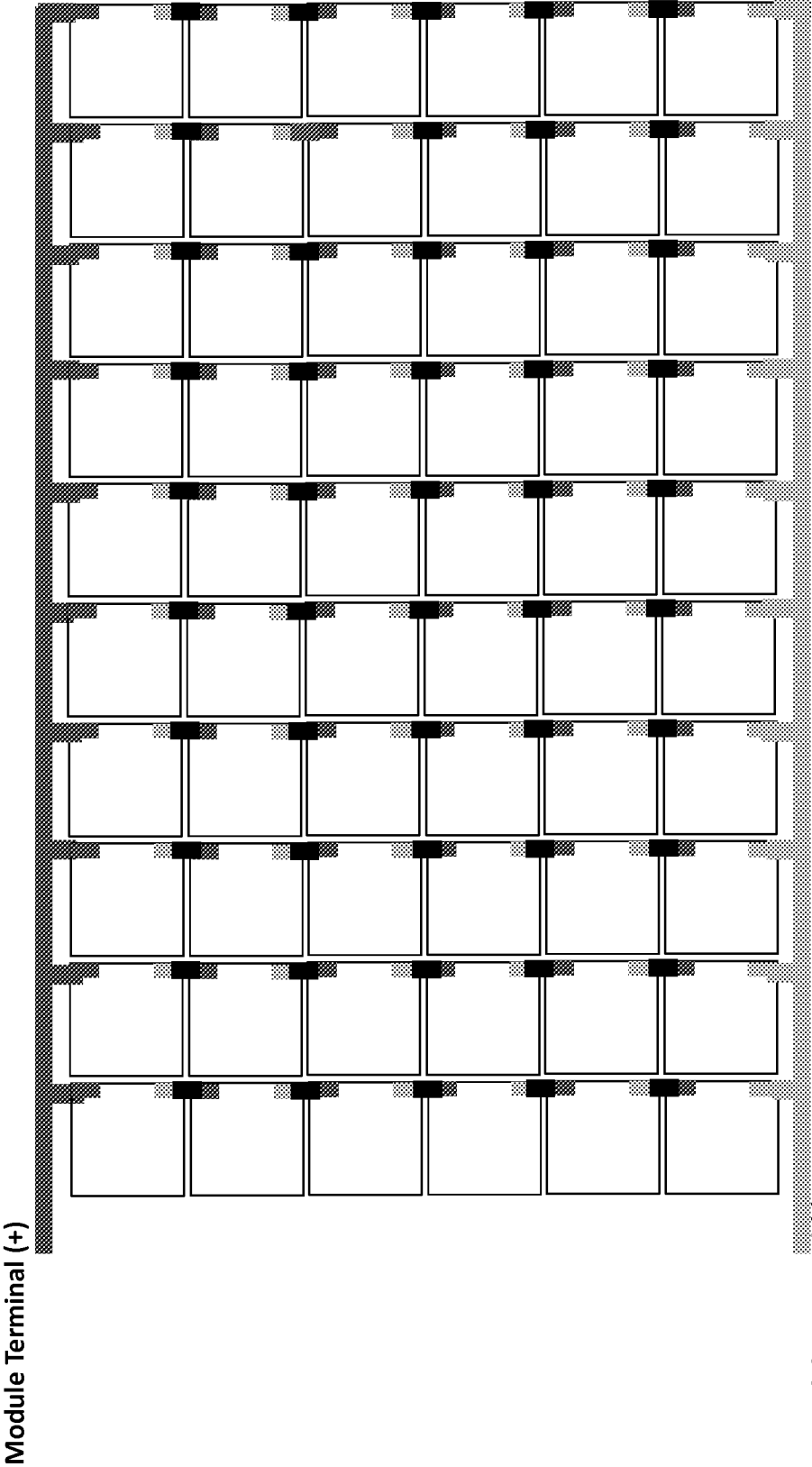
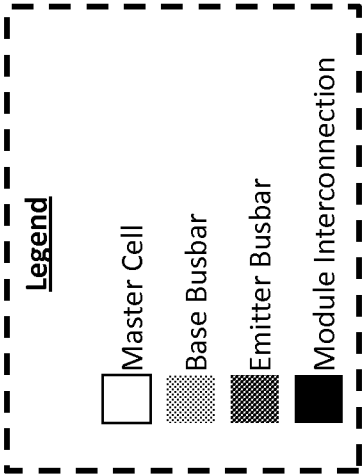


Fig. 27 Module Terminal (-)

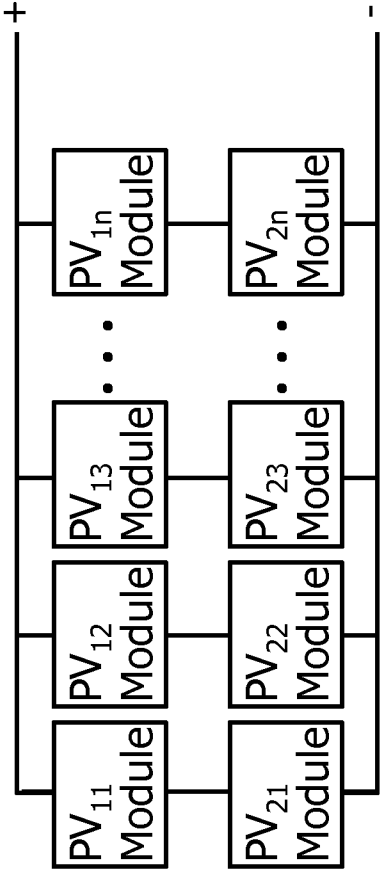


Fig. 28B

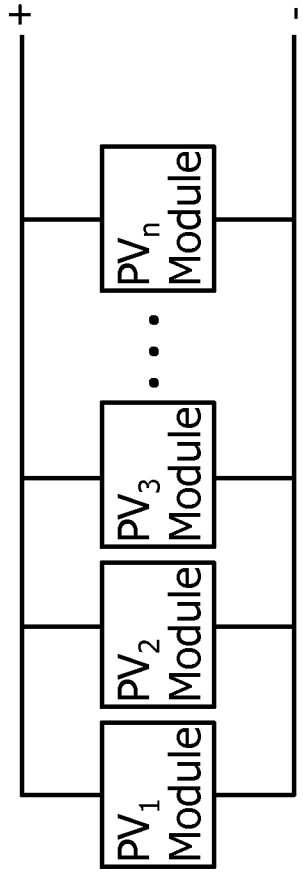


Fig. 28A

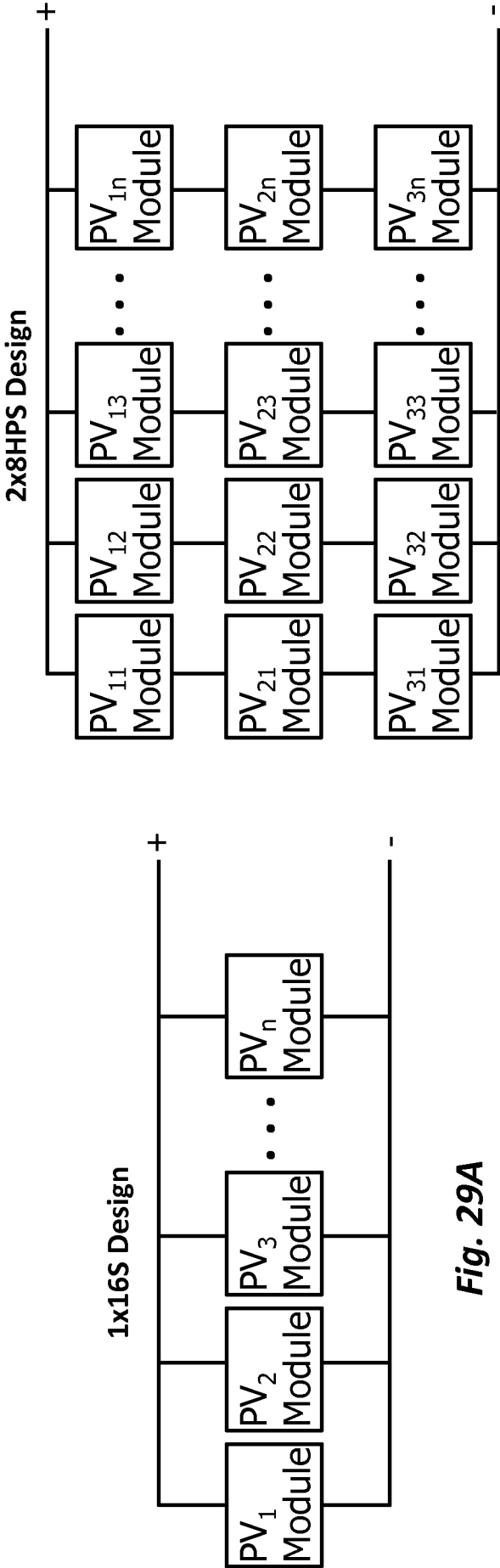


Fig. 29B

Fig. 29A

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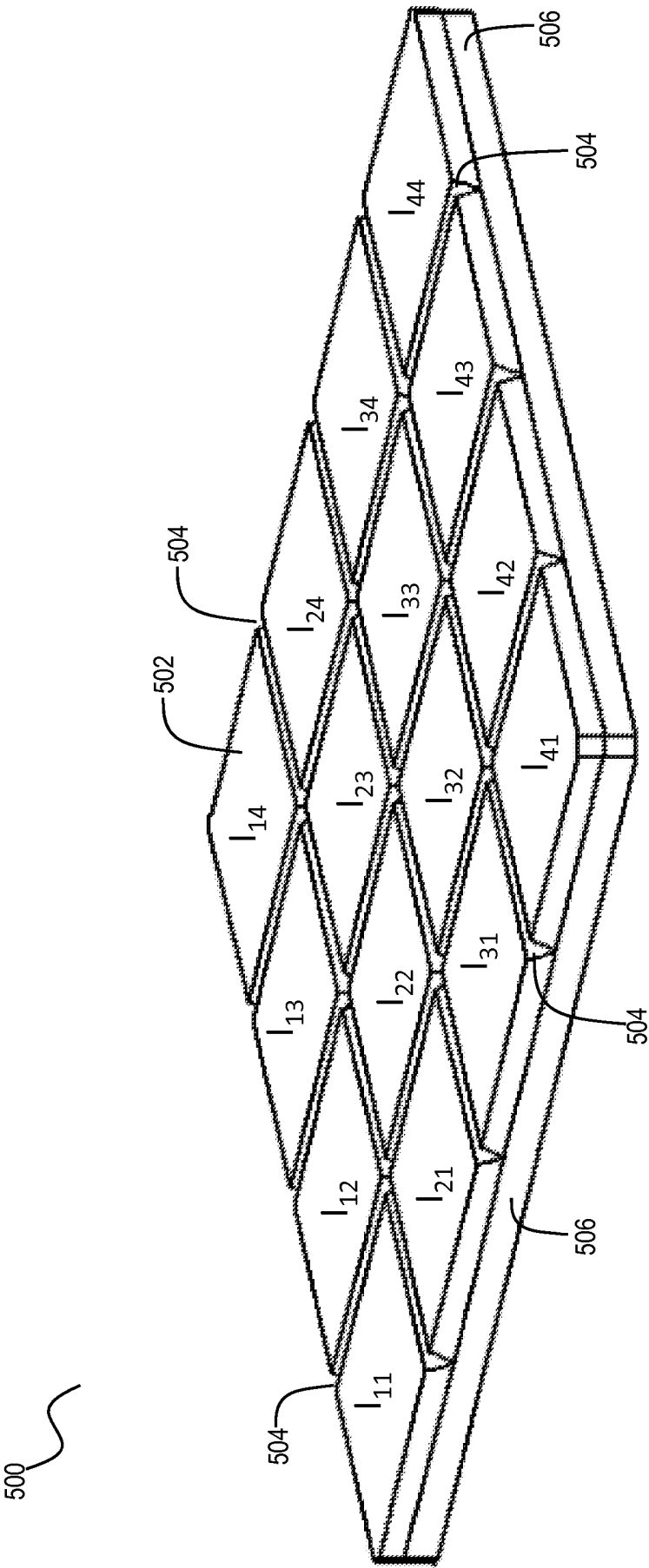


Fig. 30

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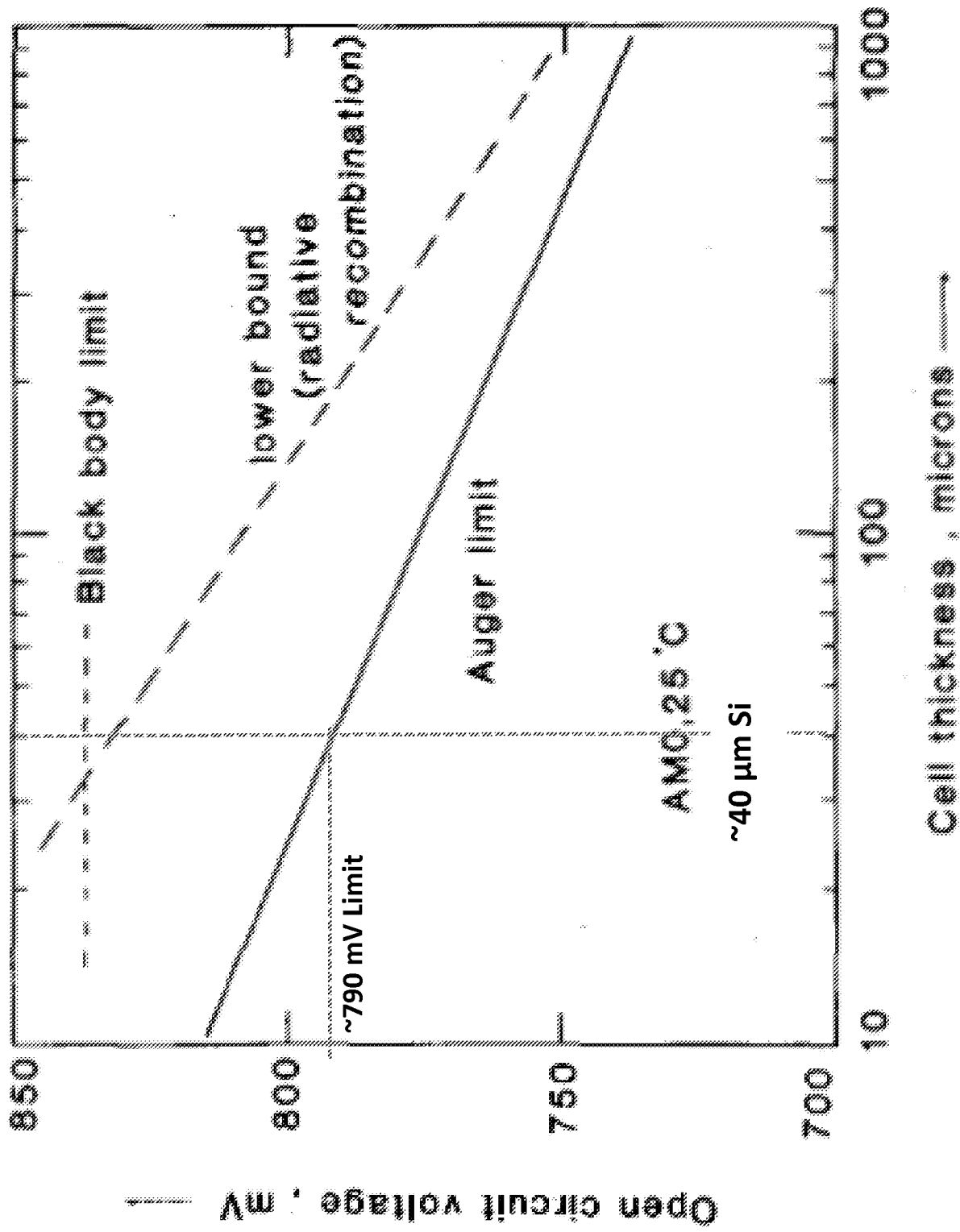


Fig. 31

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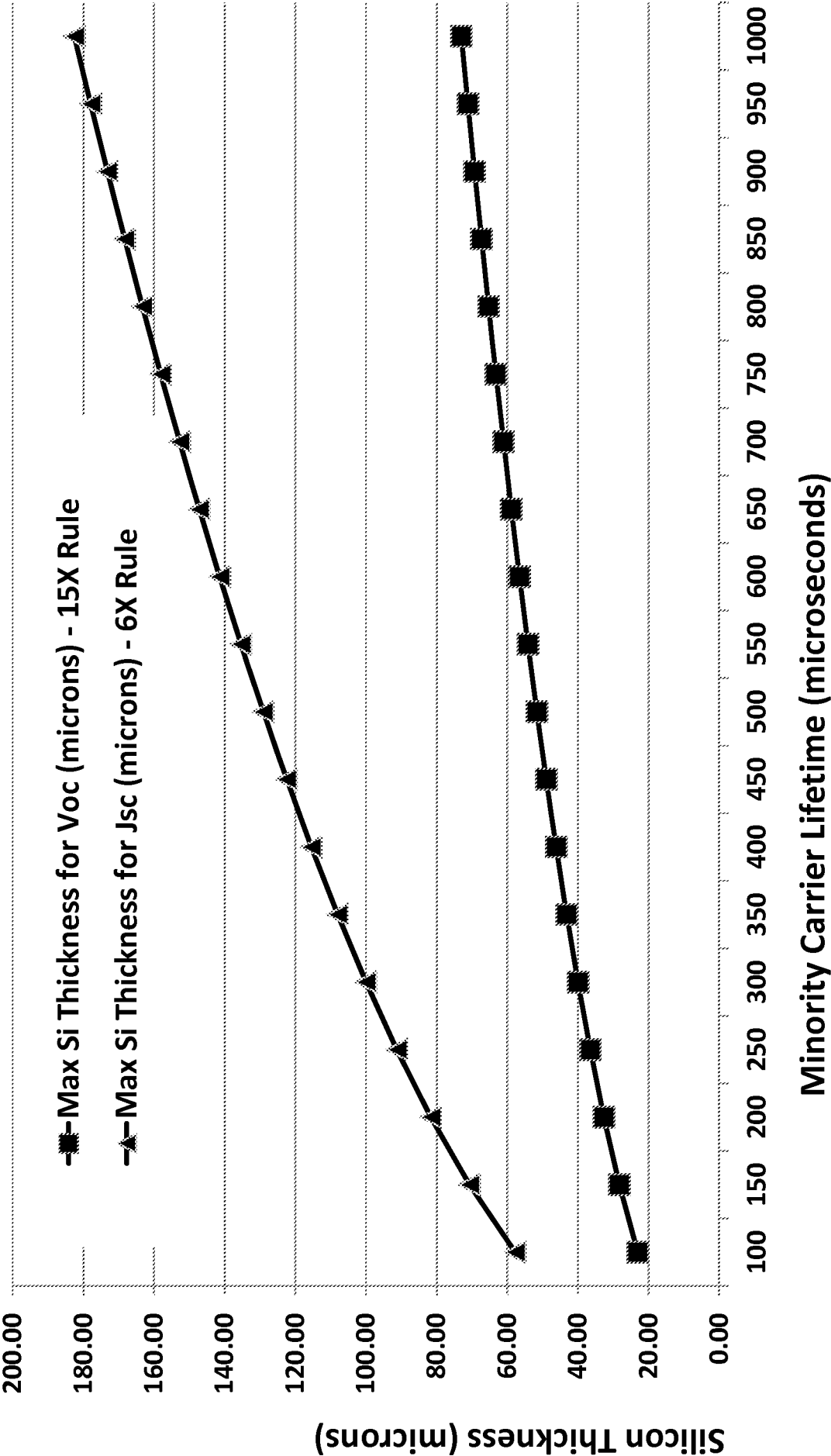


Fig. 32

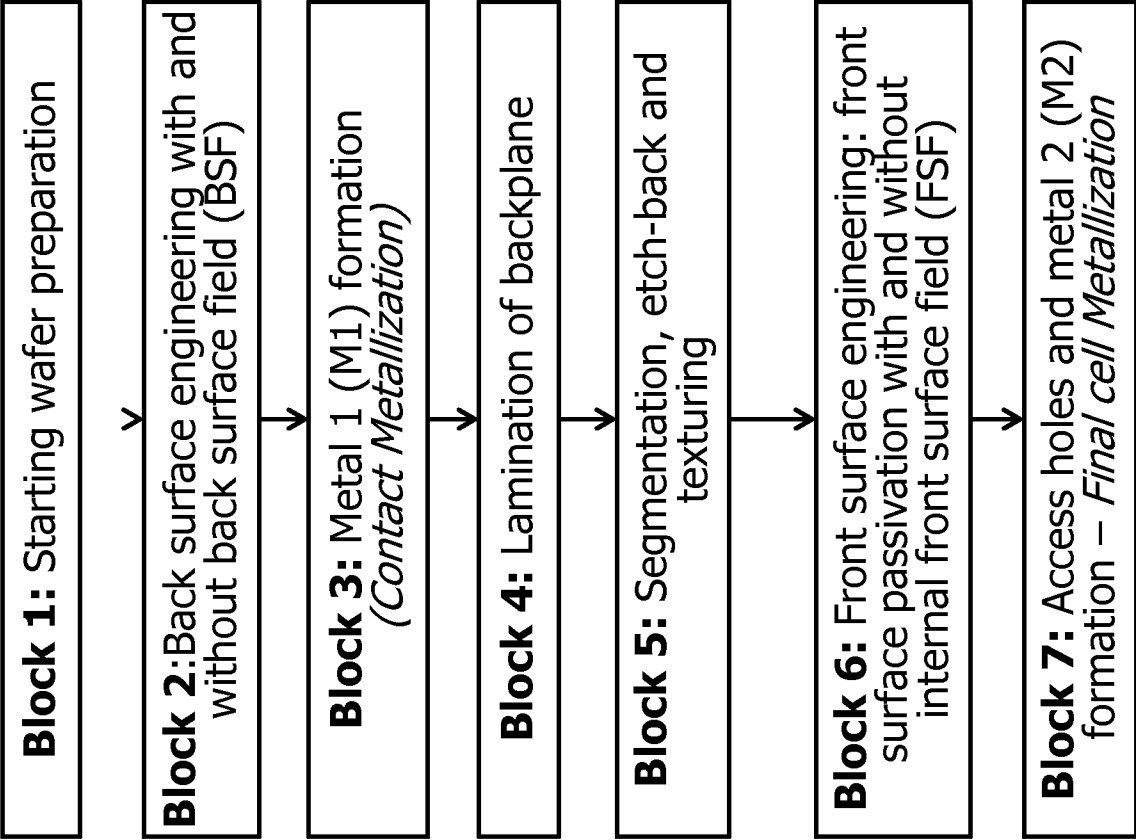


Fig. 33

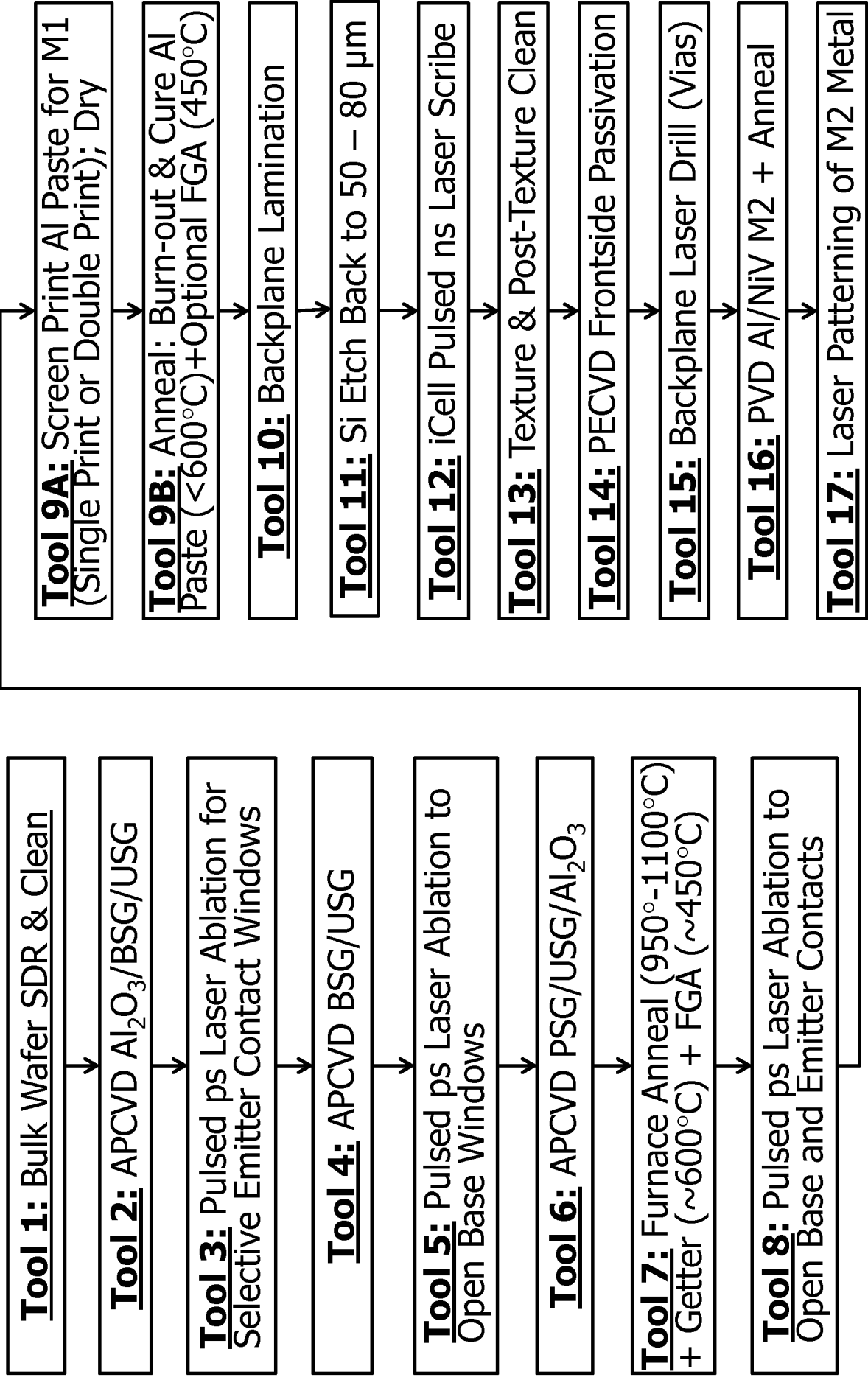


Fig. 34A

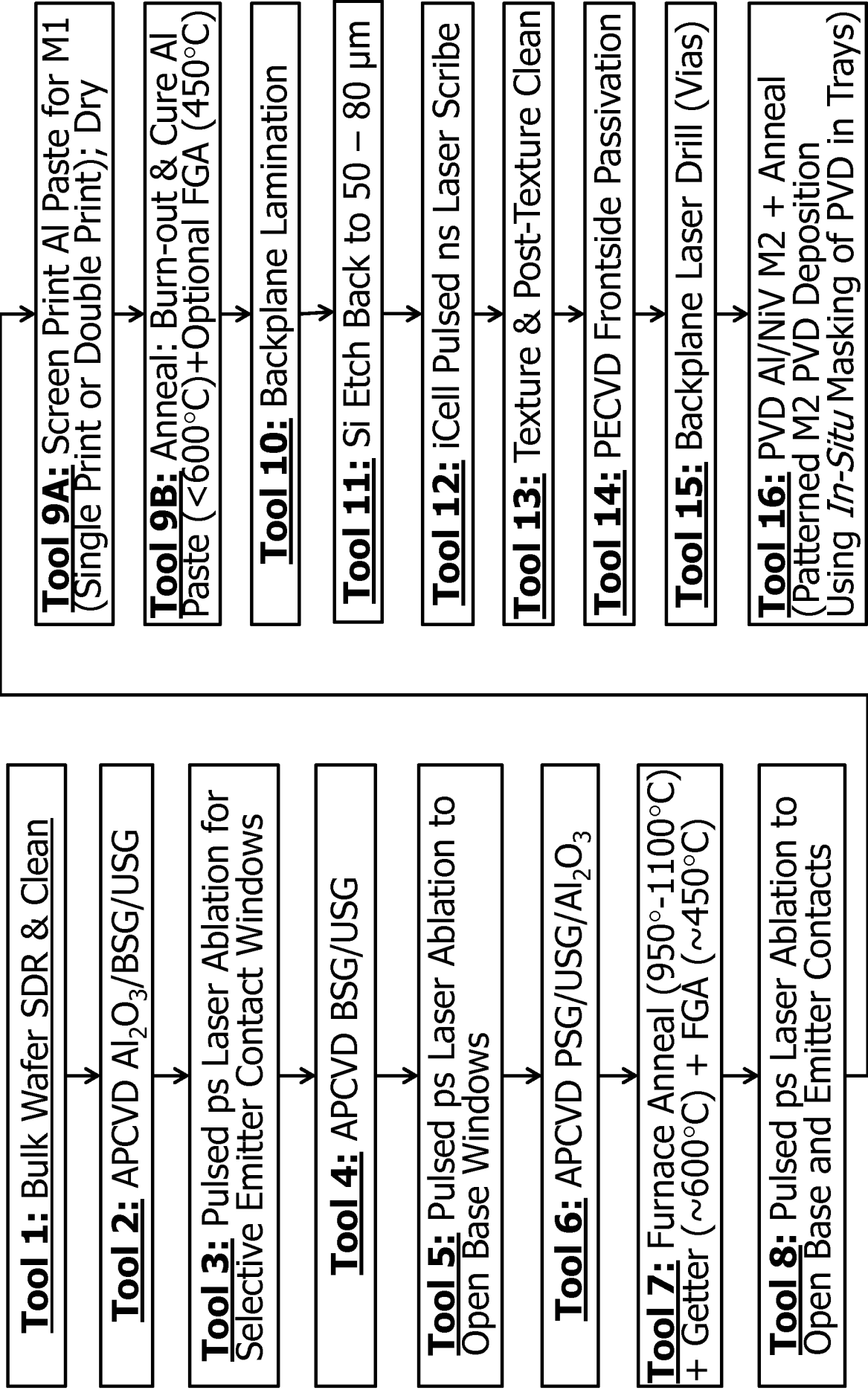


Fig. 34B

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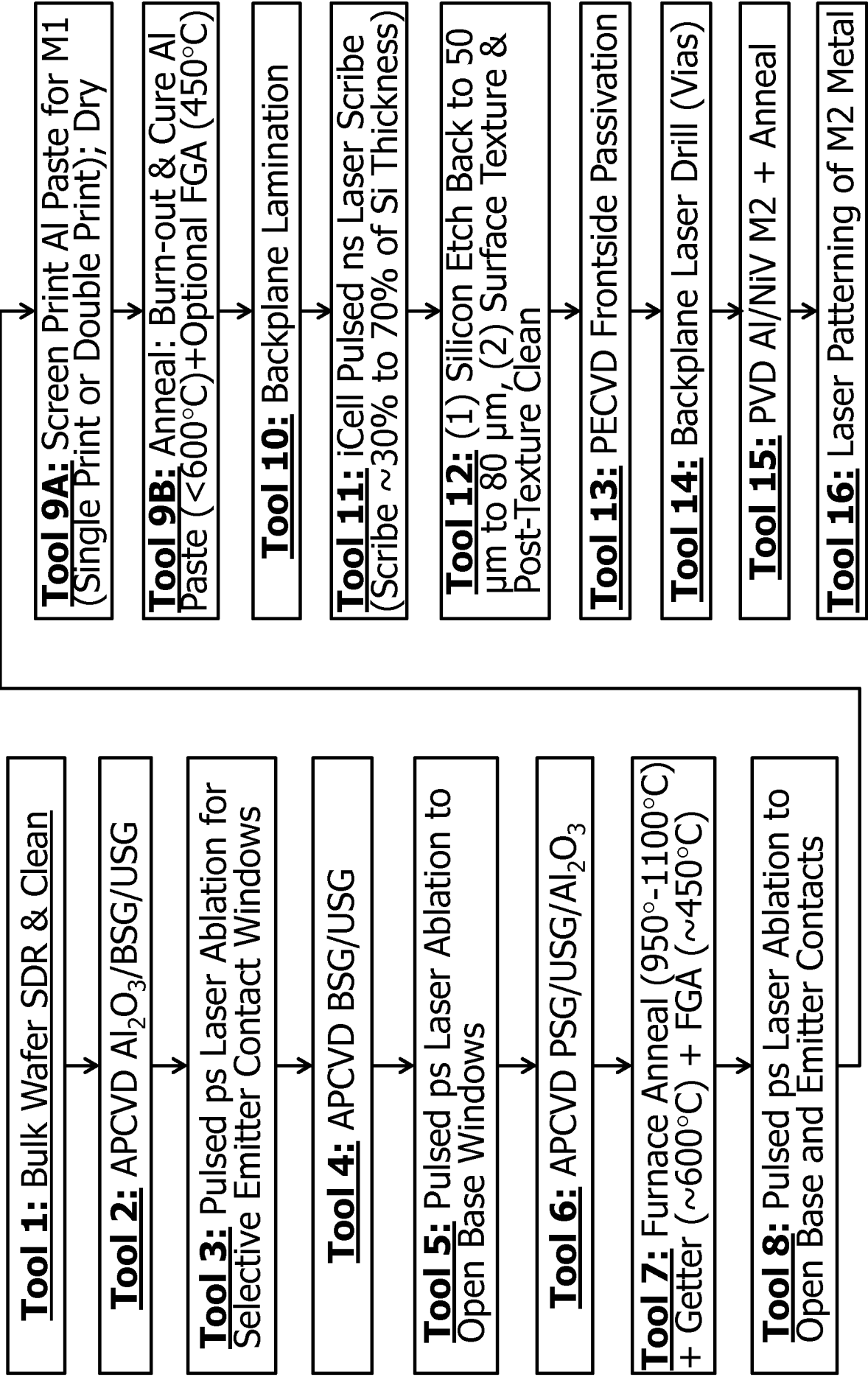


Fig. 34C

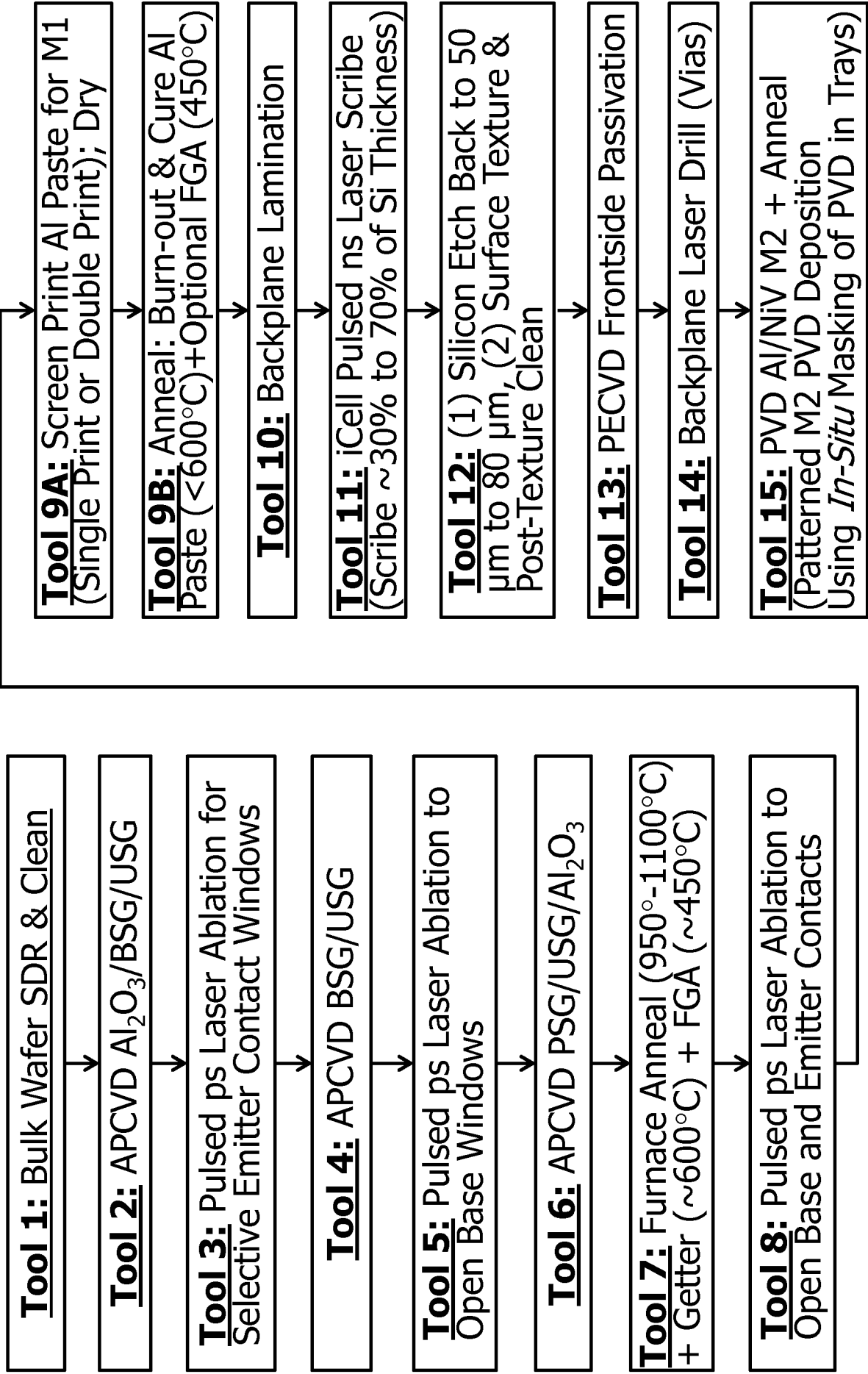


Fig. 34D

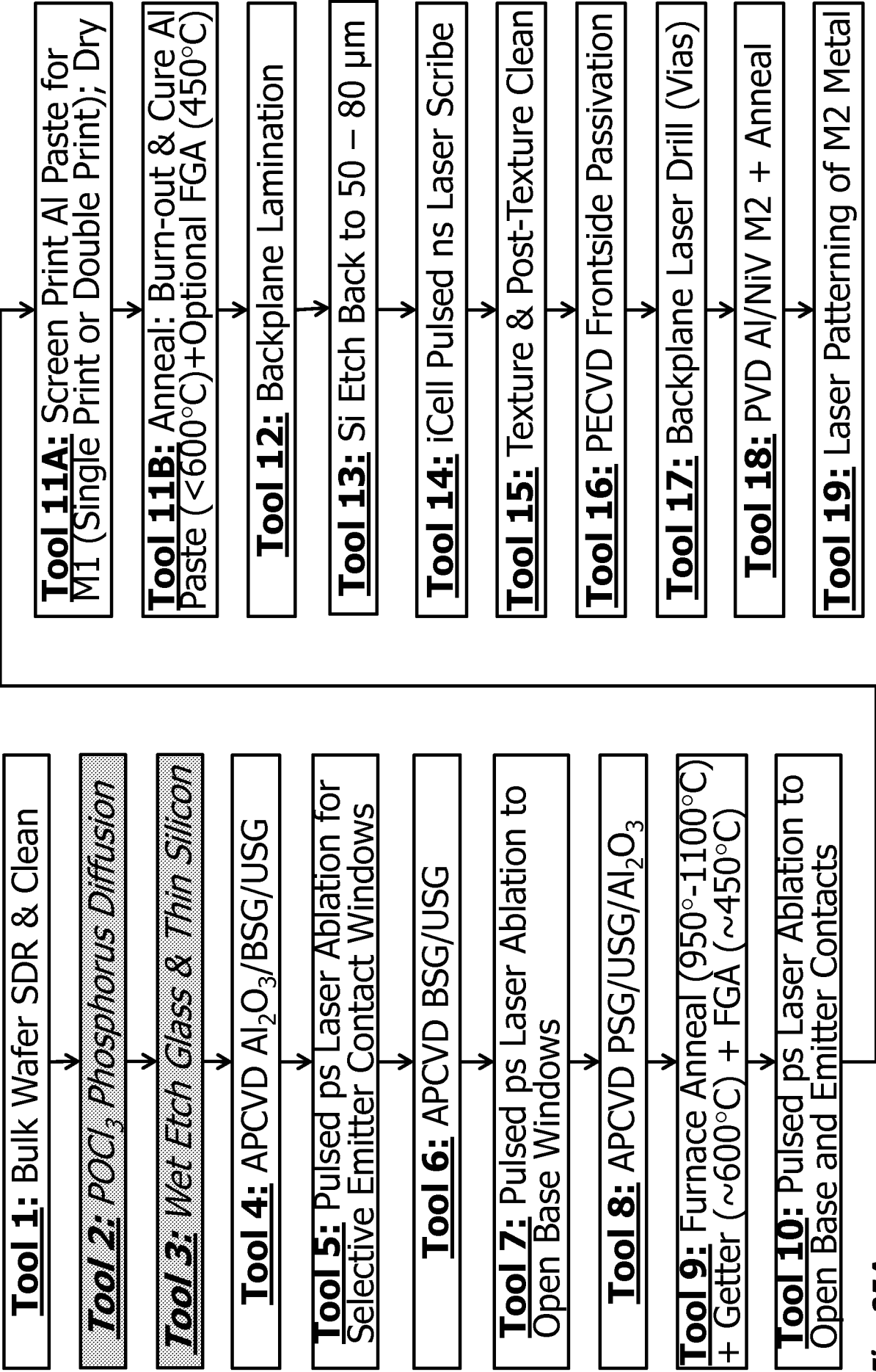


Fig. 35A

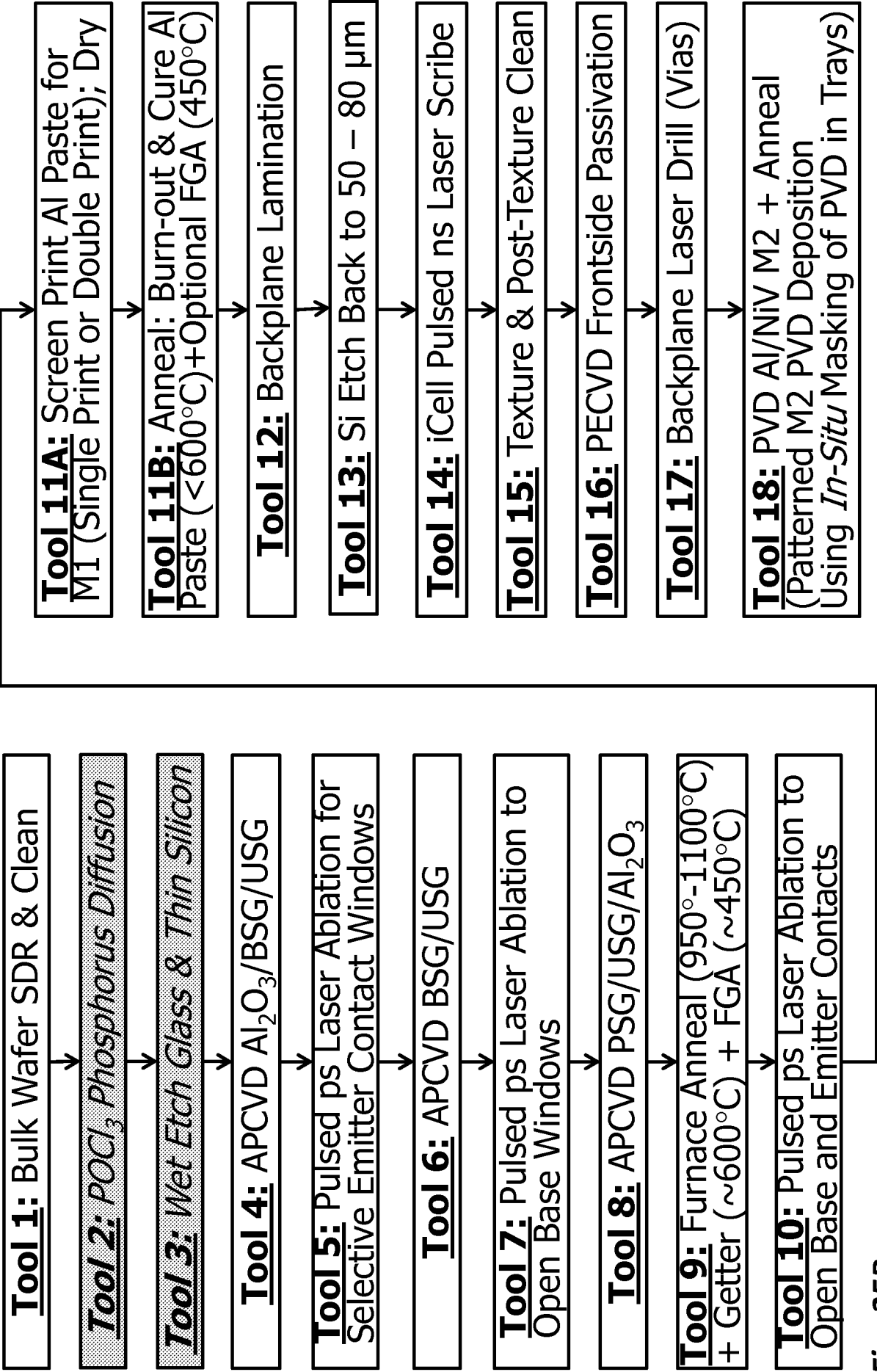


Fig. 35B

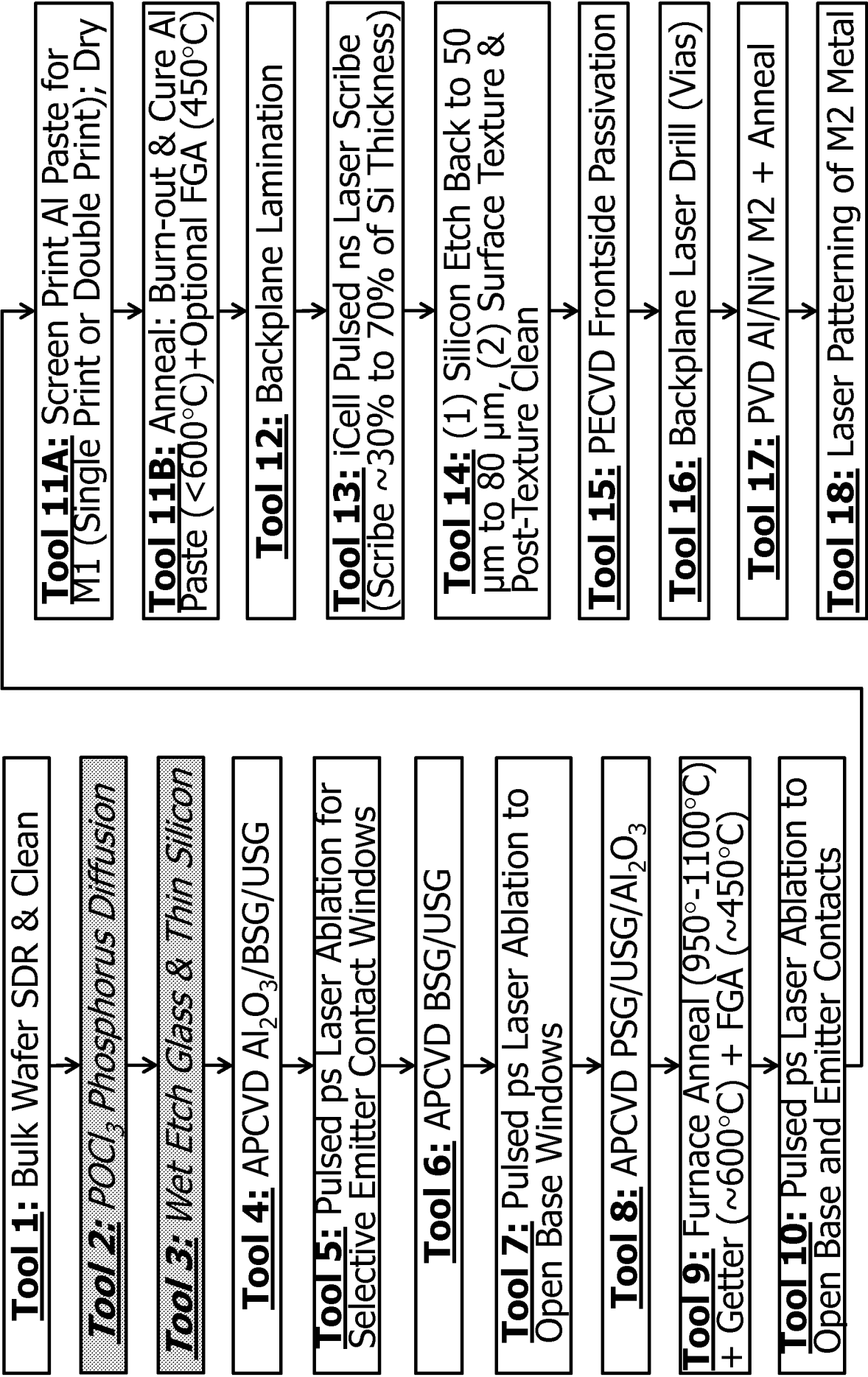


Fig. 35C

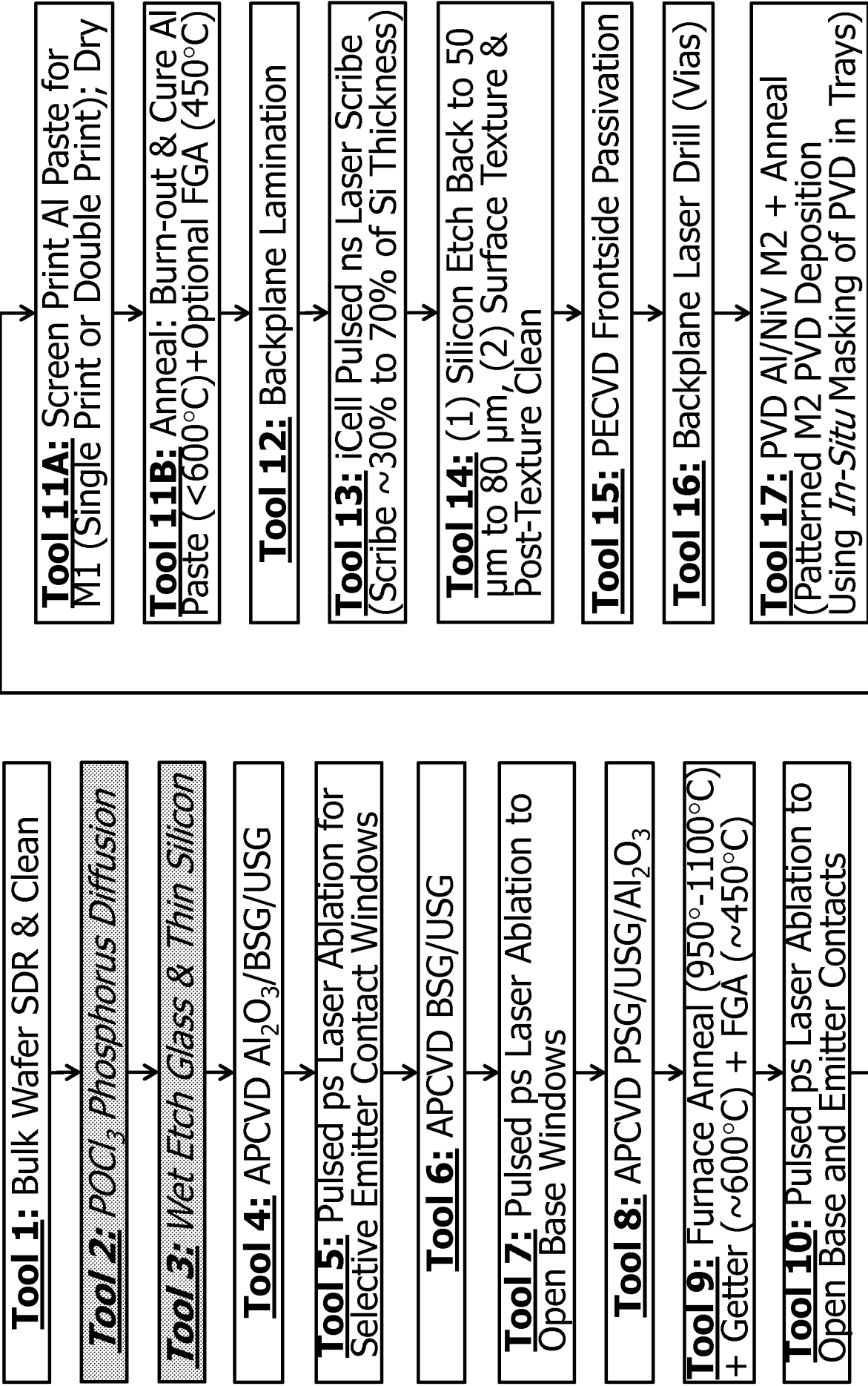


Fig. 35D

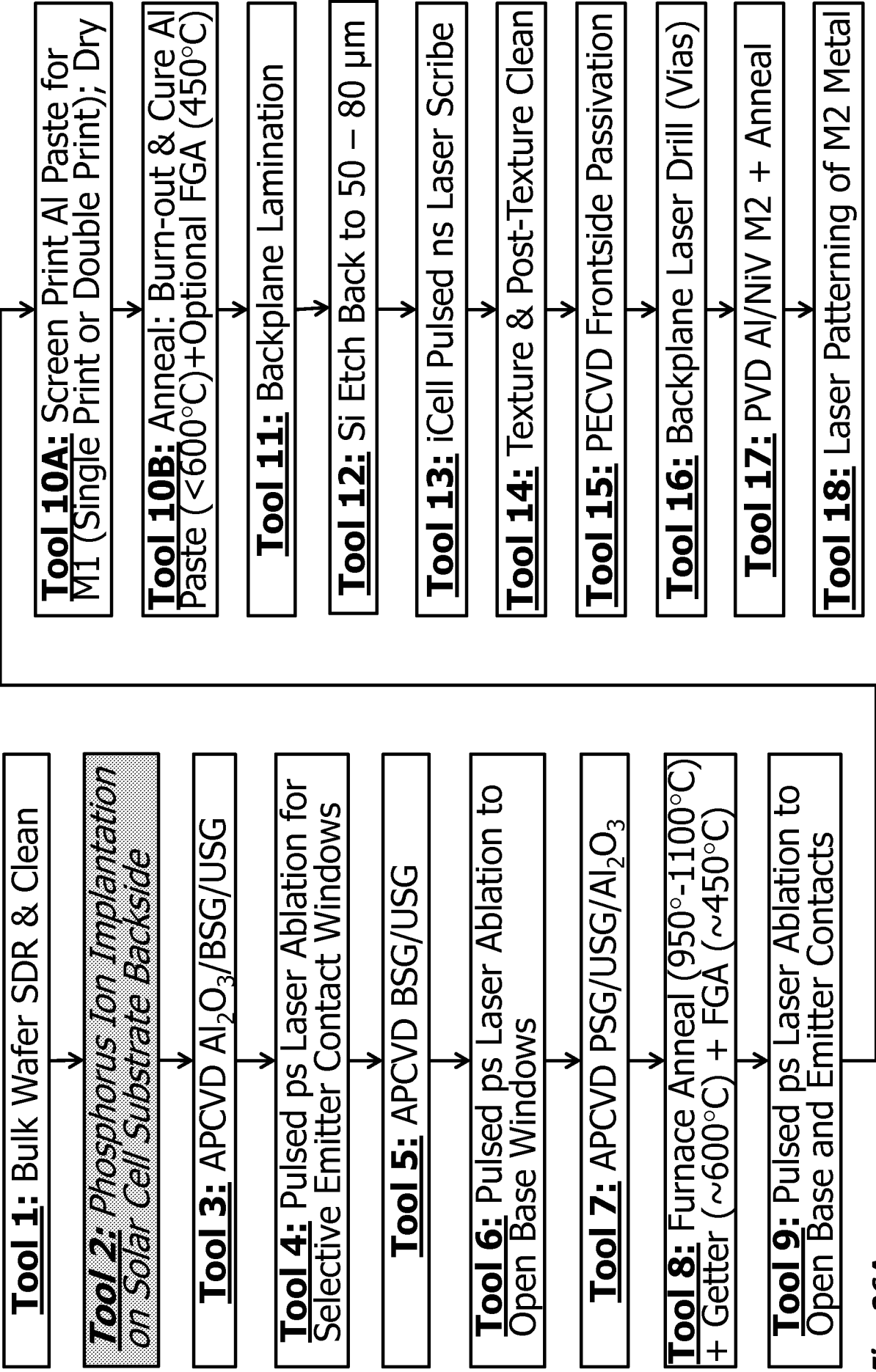


Fig. 36A

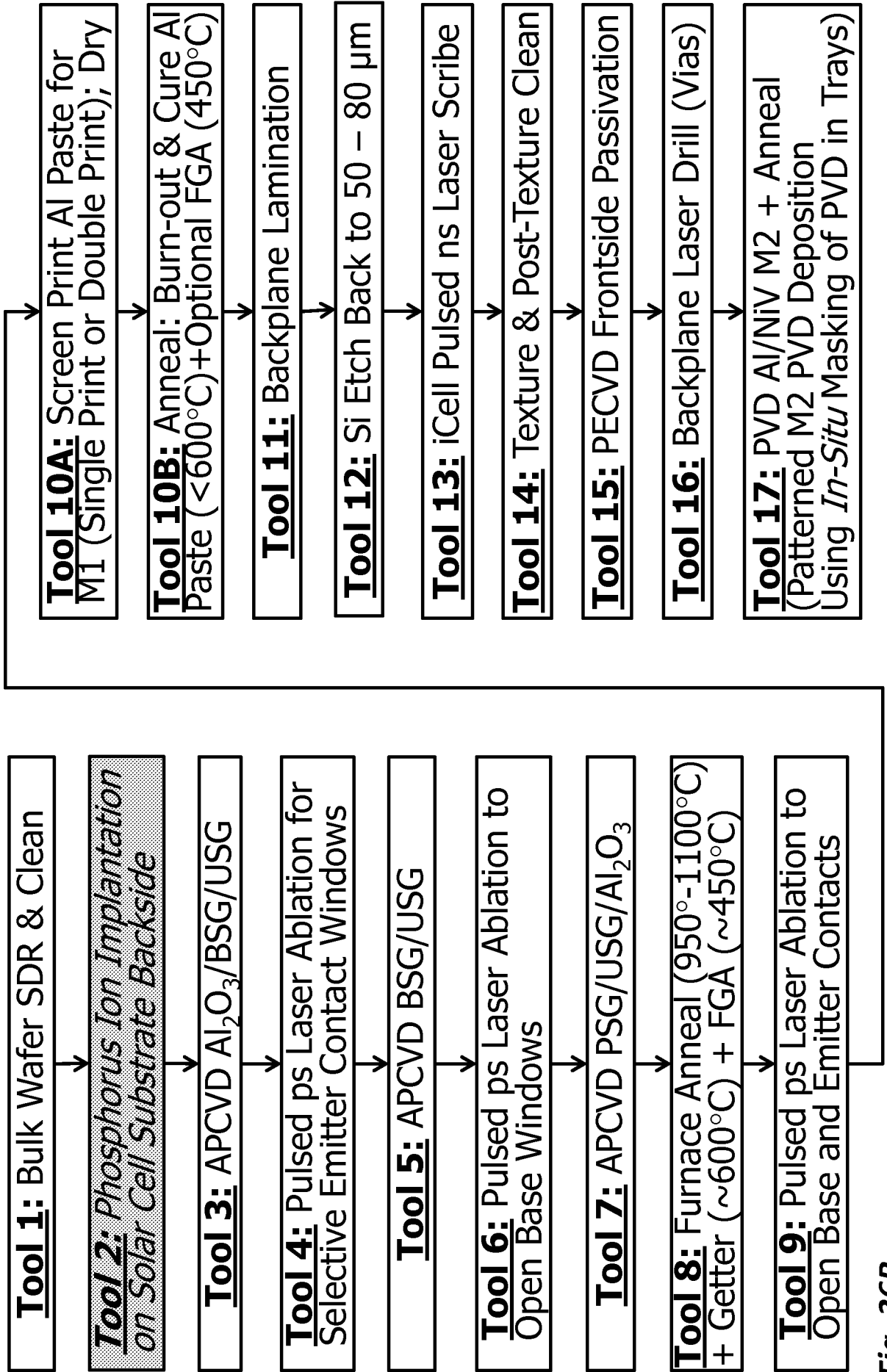


Fig. 36B

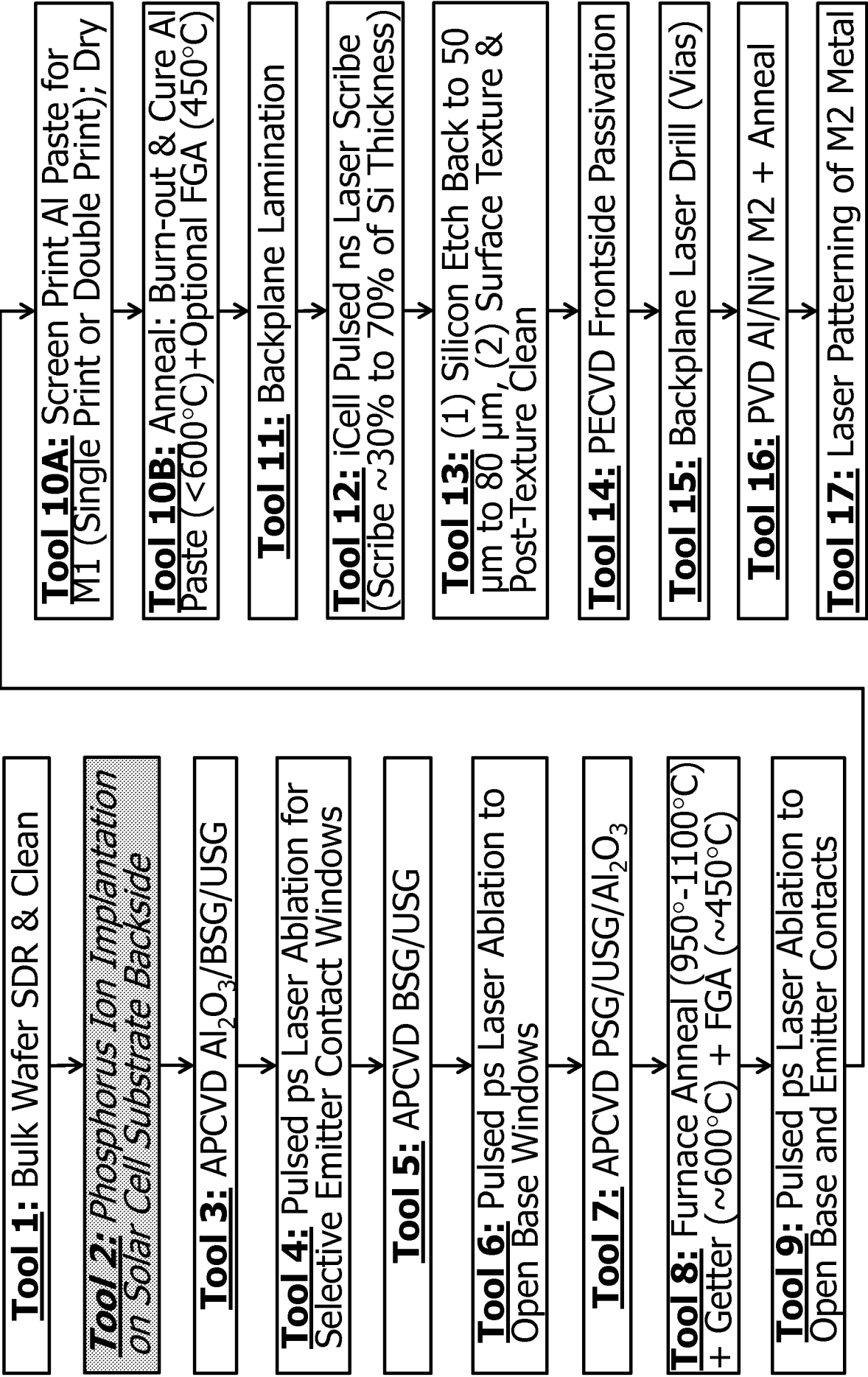


Fig. 36C

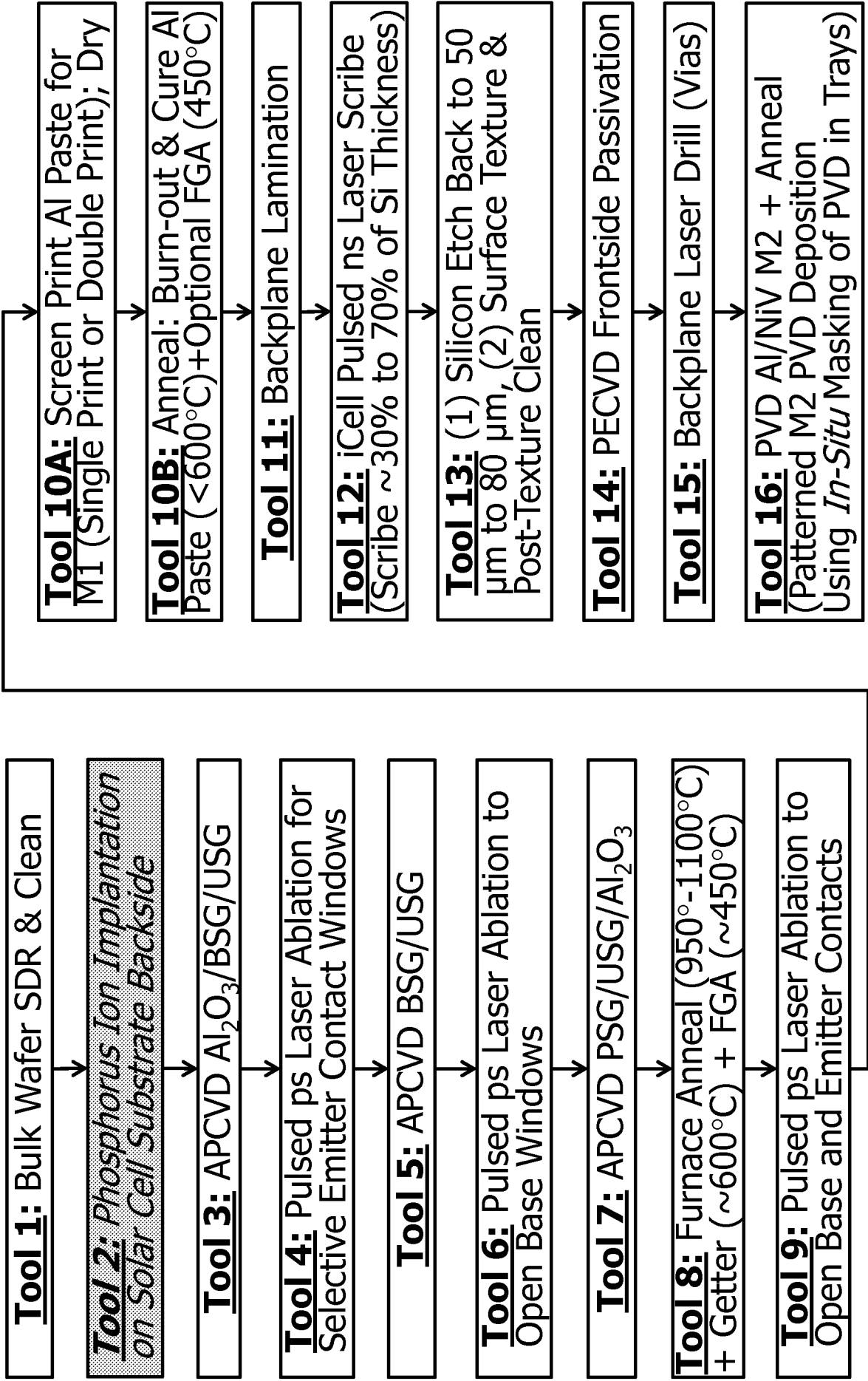


Fig. 36D

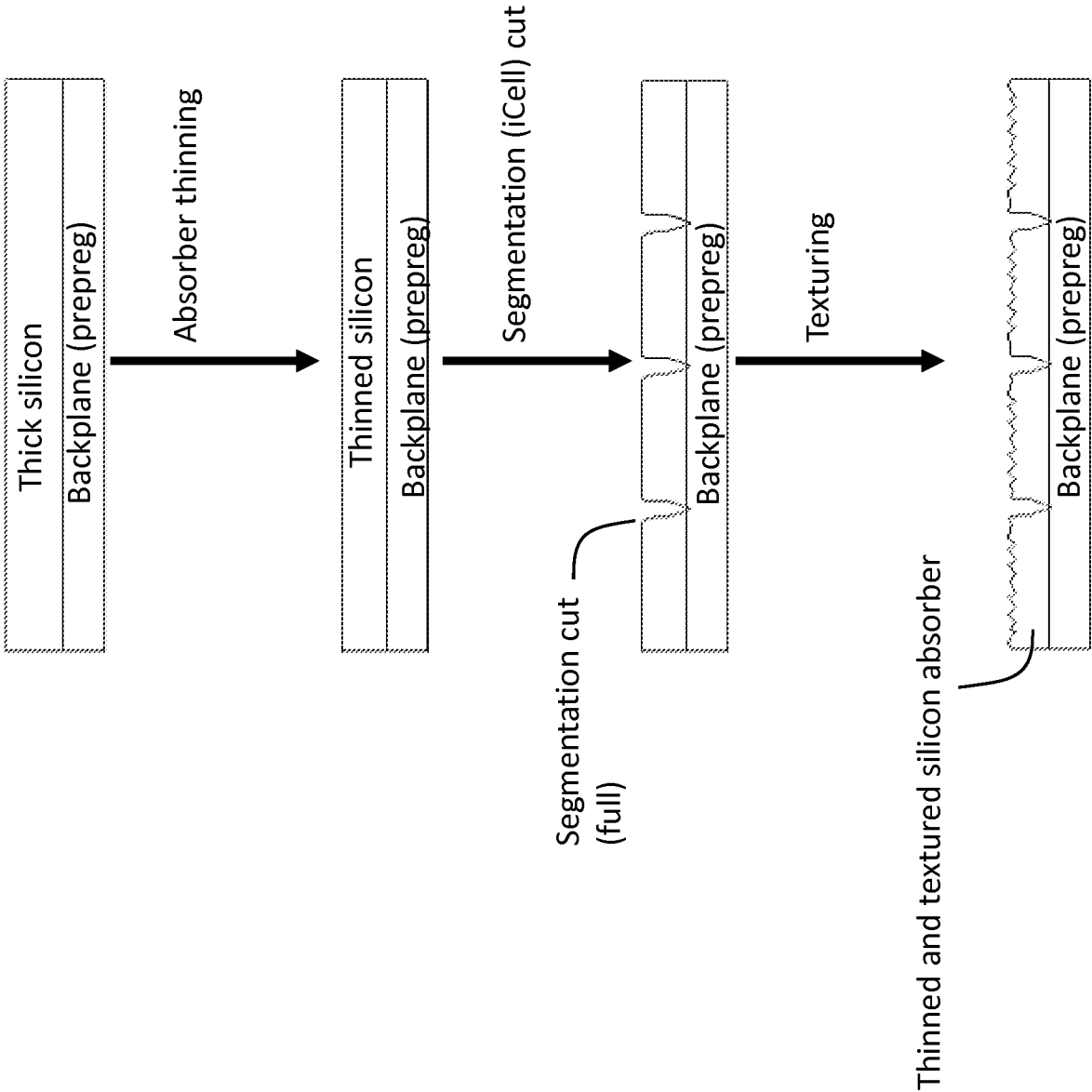


Fig. 37A

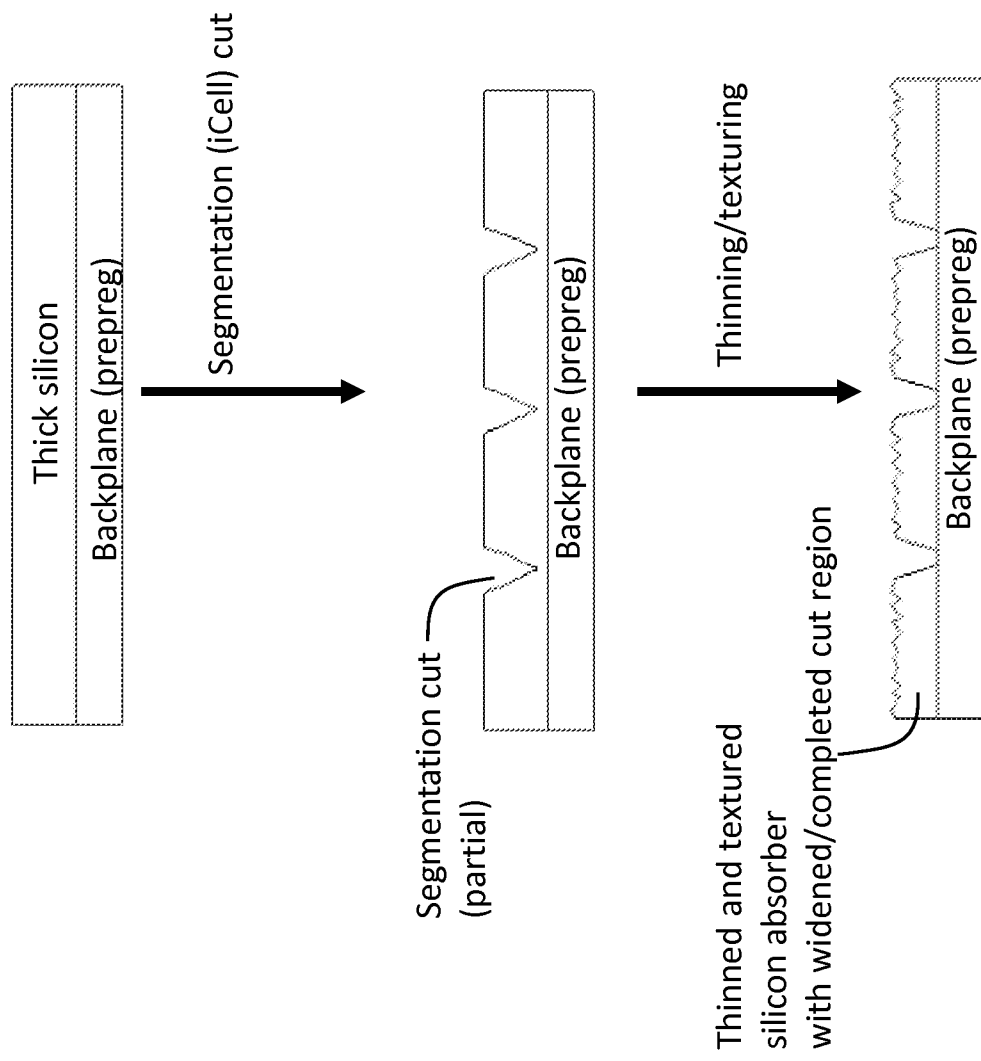


Fig. 37B

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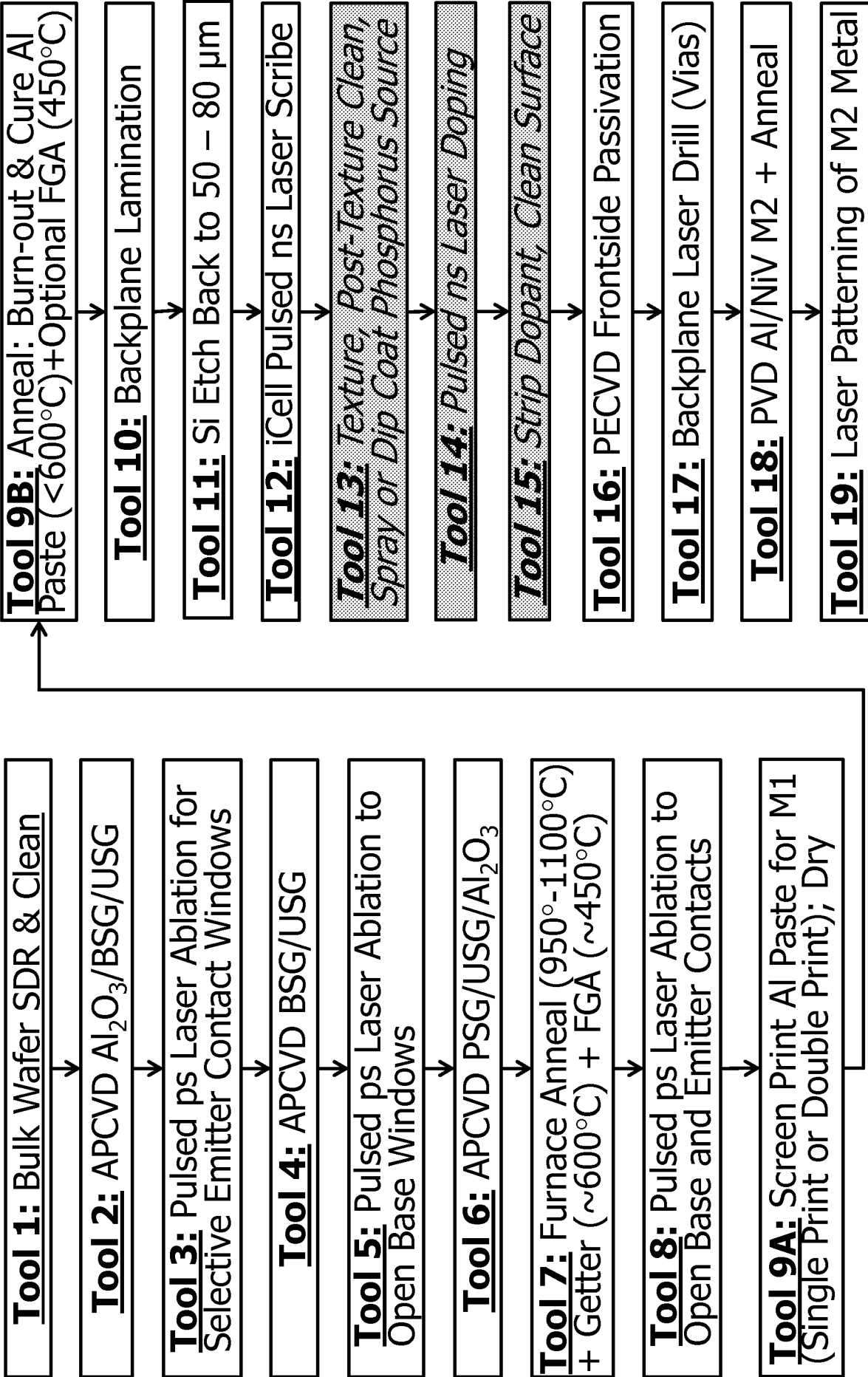


Fig. 38A

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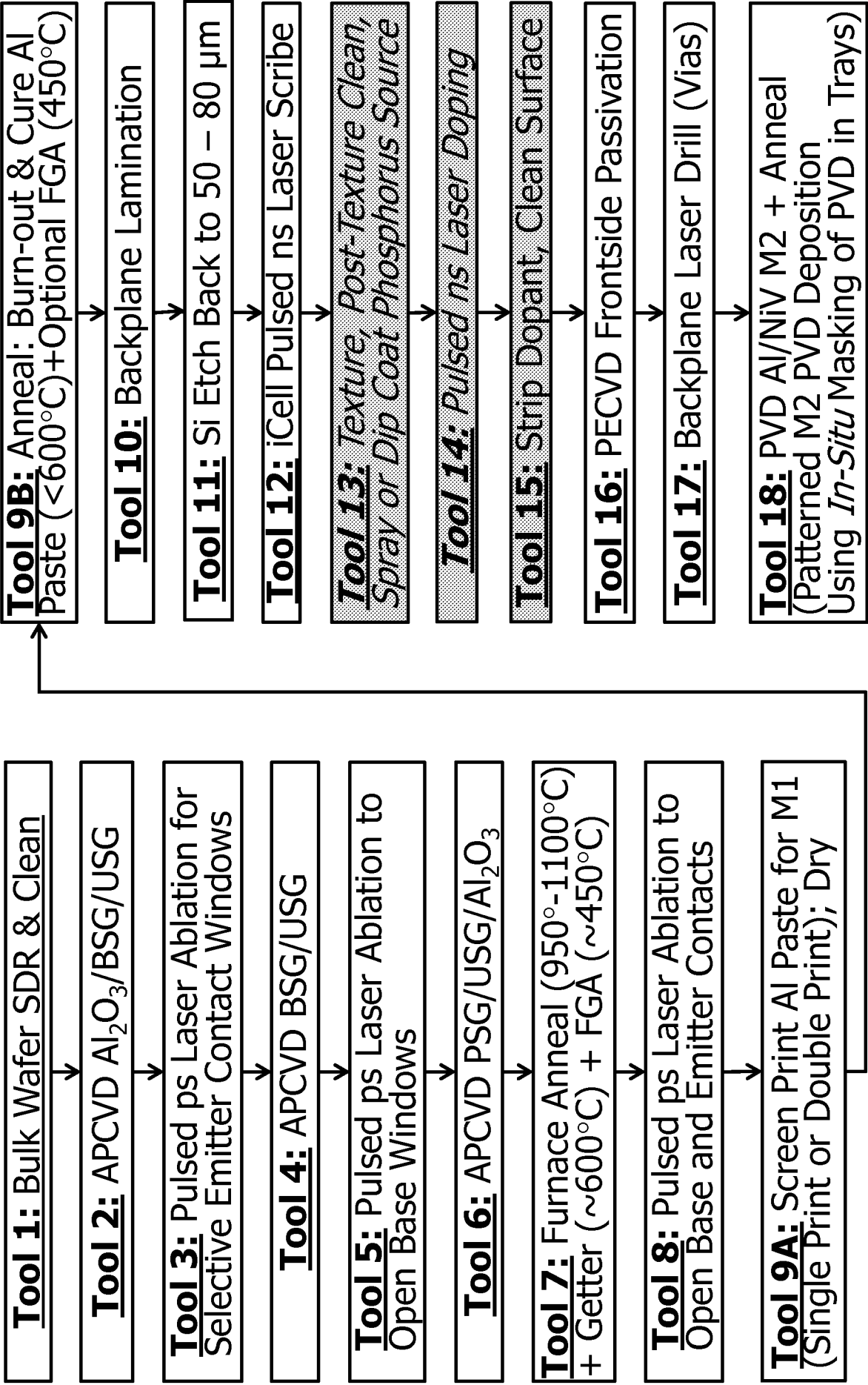


Fig. 38B

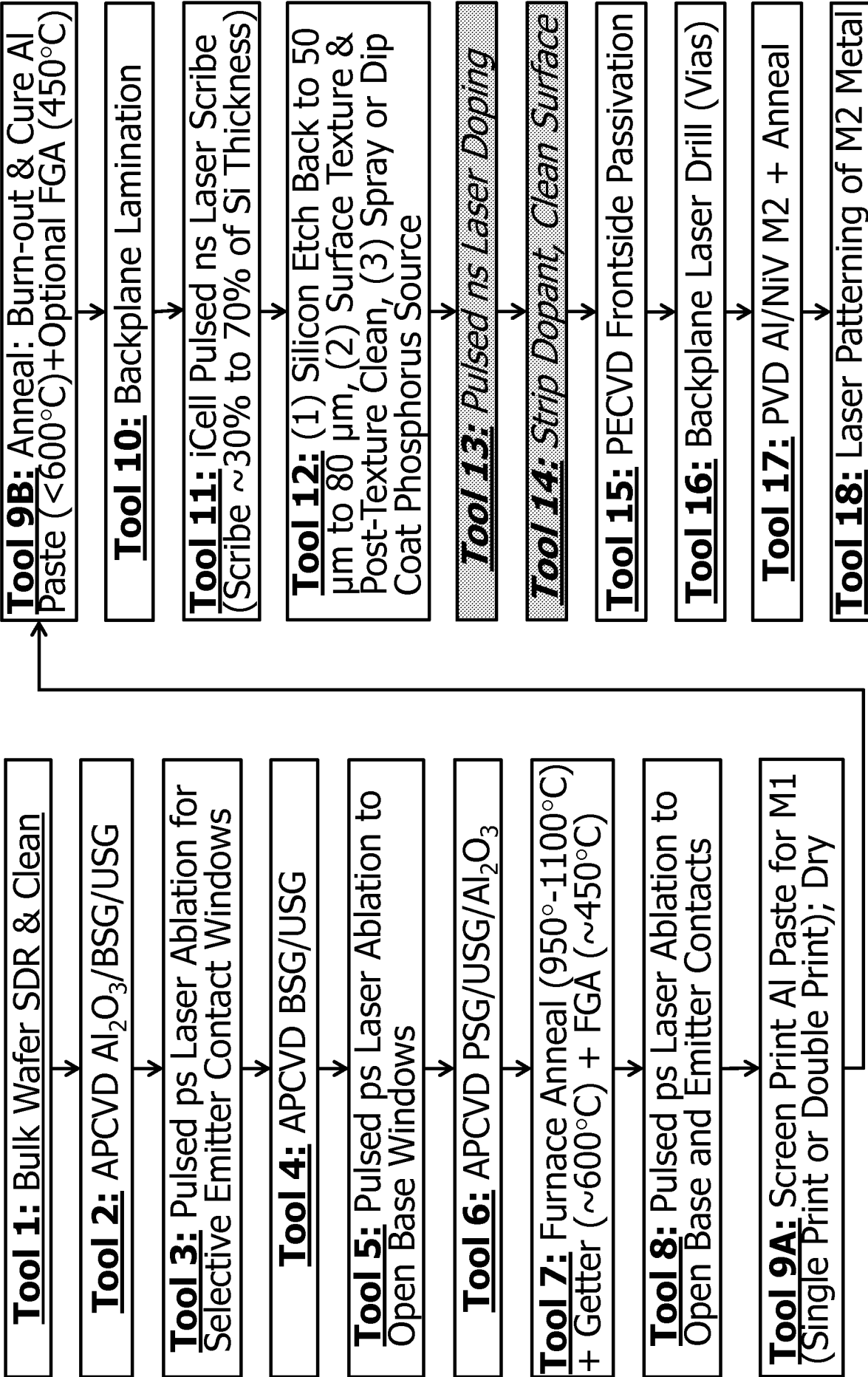


Fig. 38C

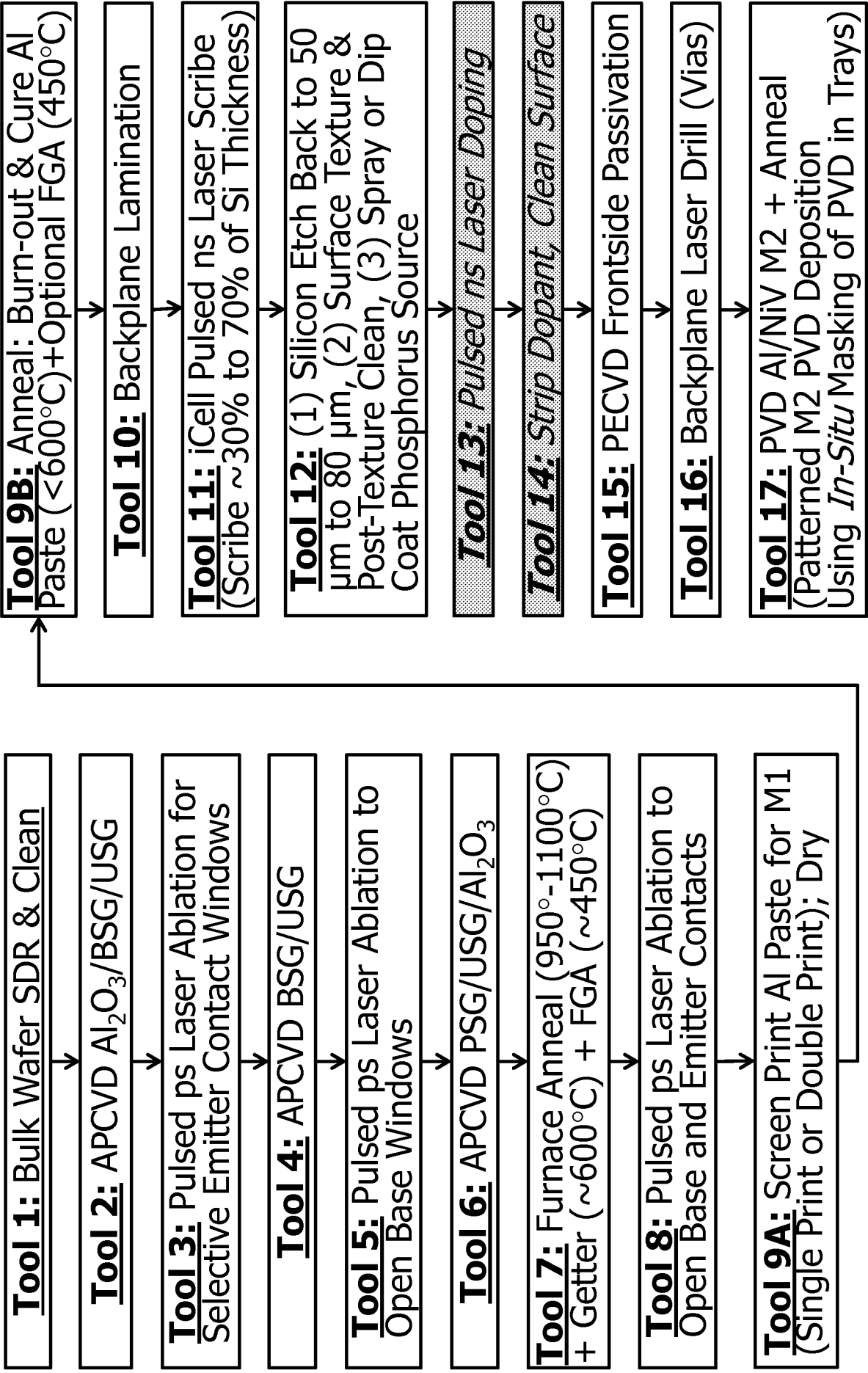


Fig. 38D

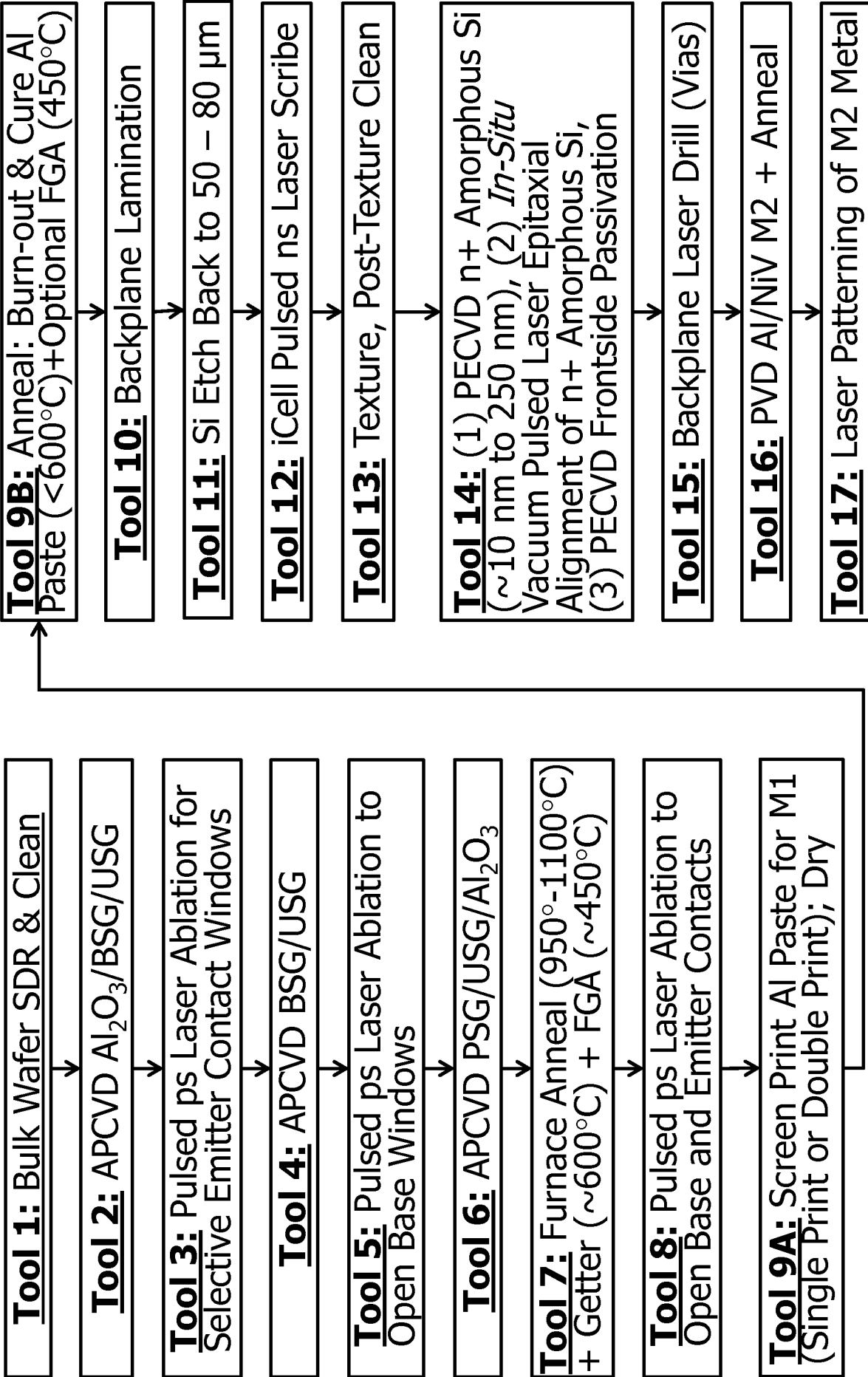


Fig. 39A

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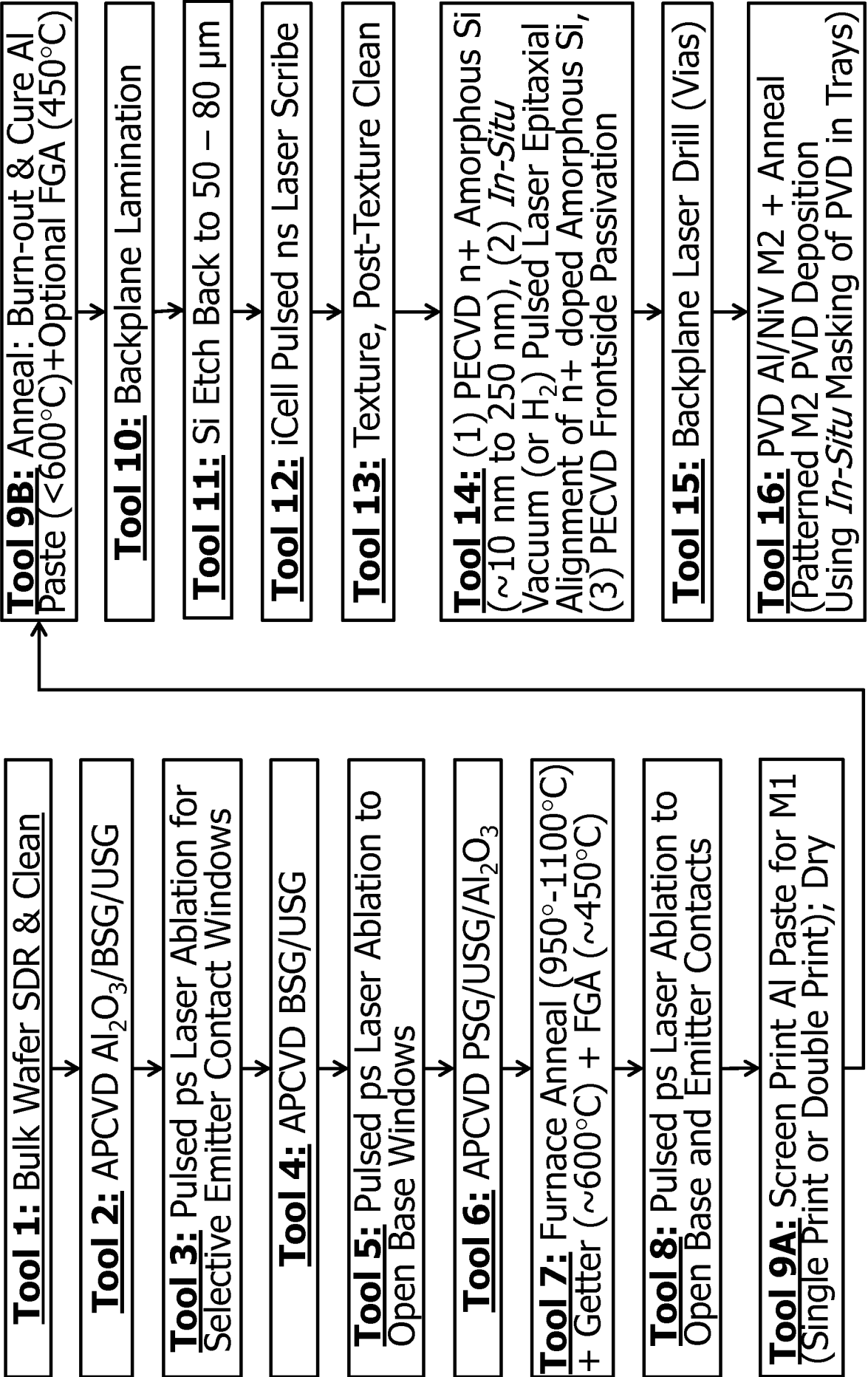


Fig. 39B

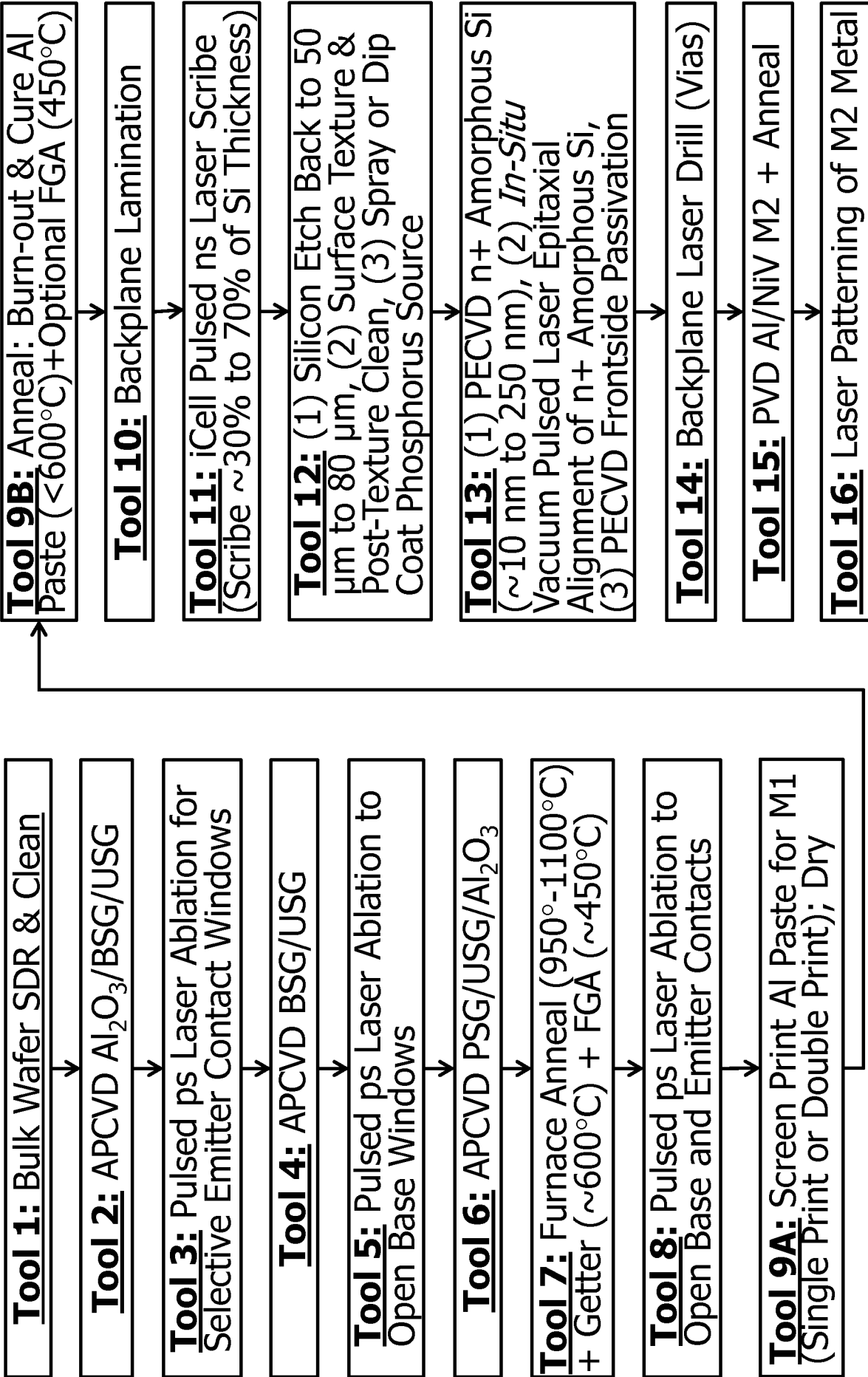


Fig. 39C

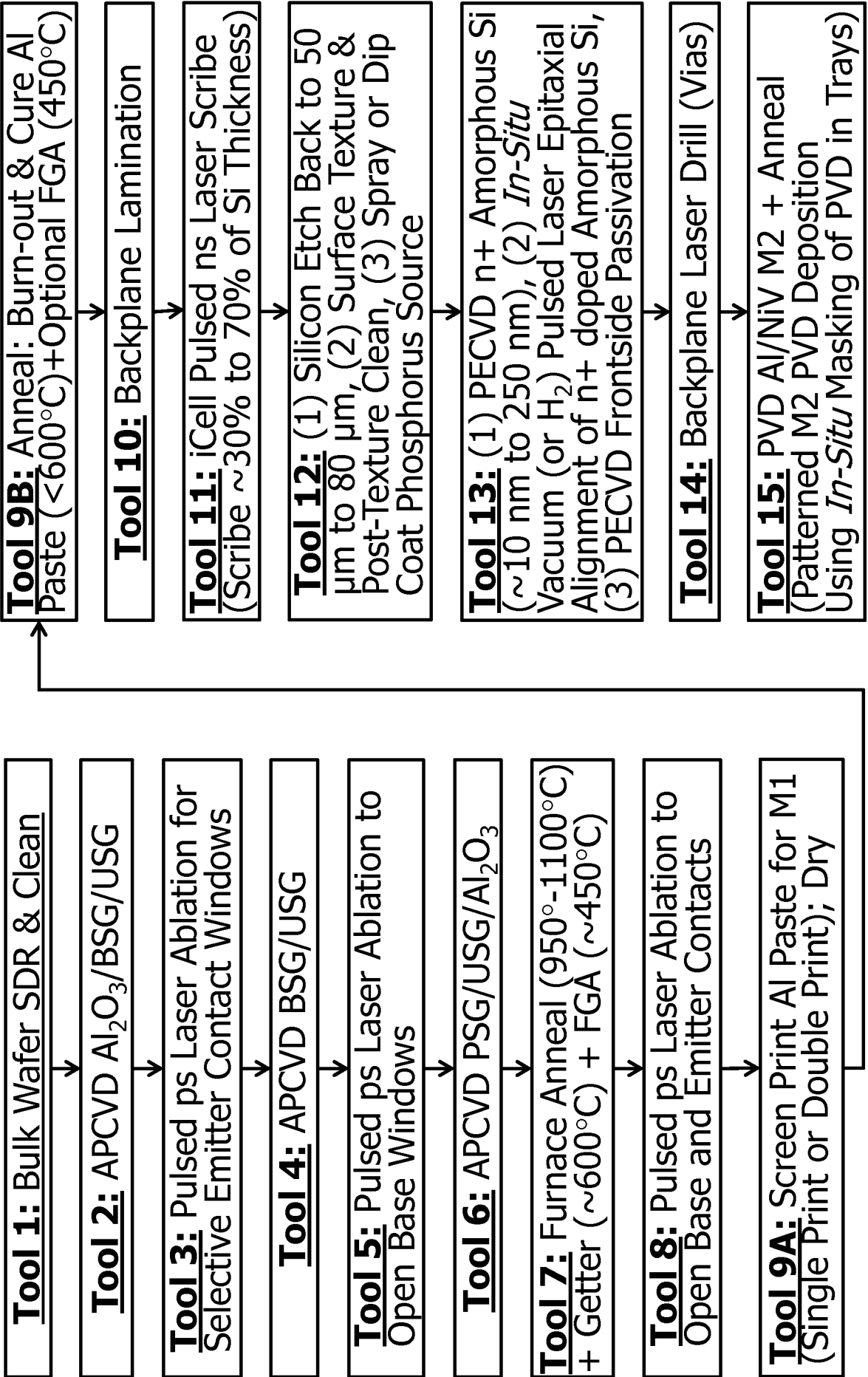


Fig. 39D

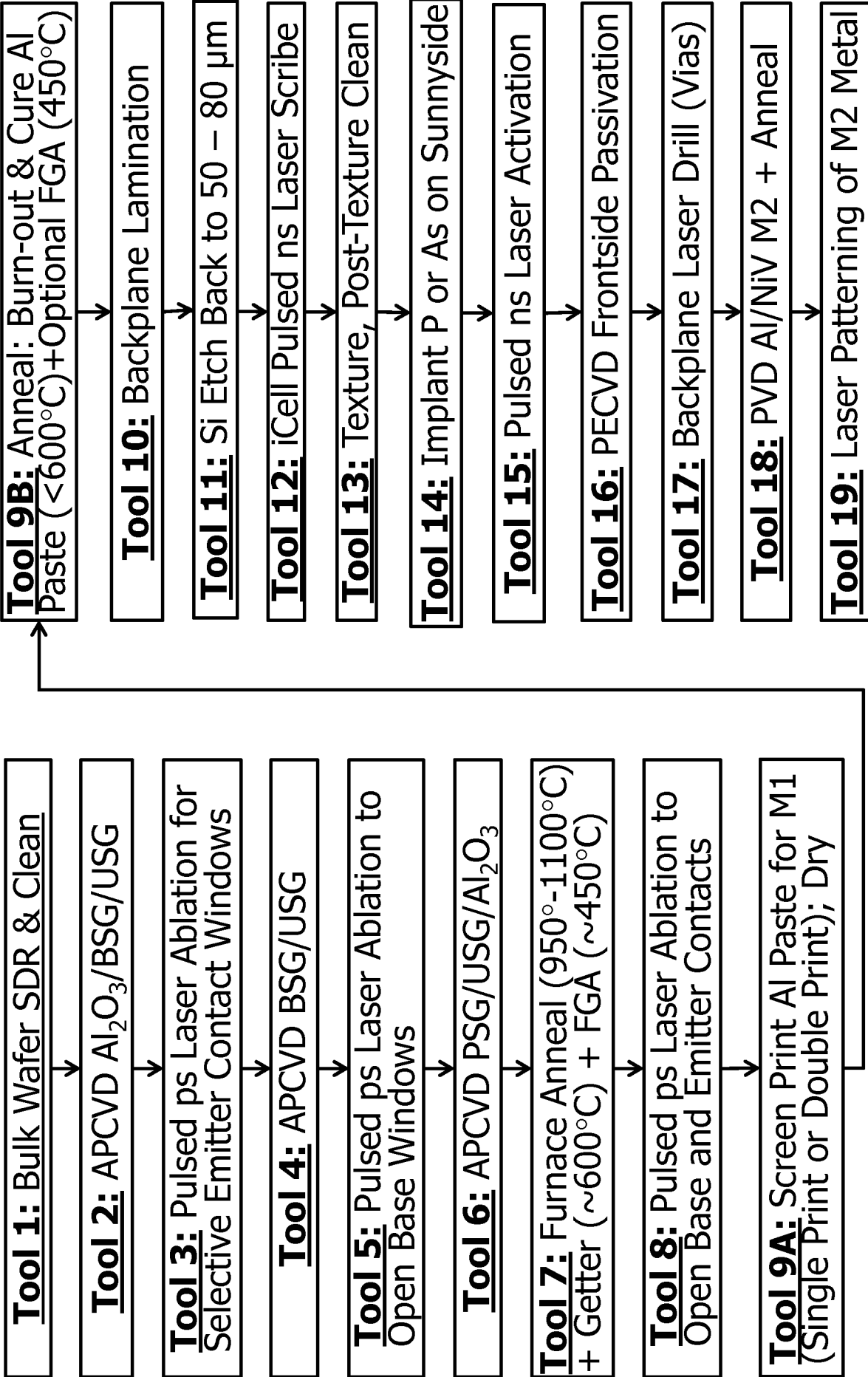


Fig. 40A

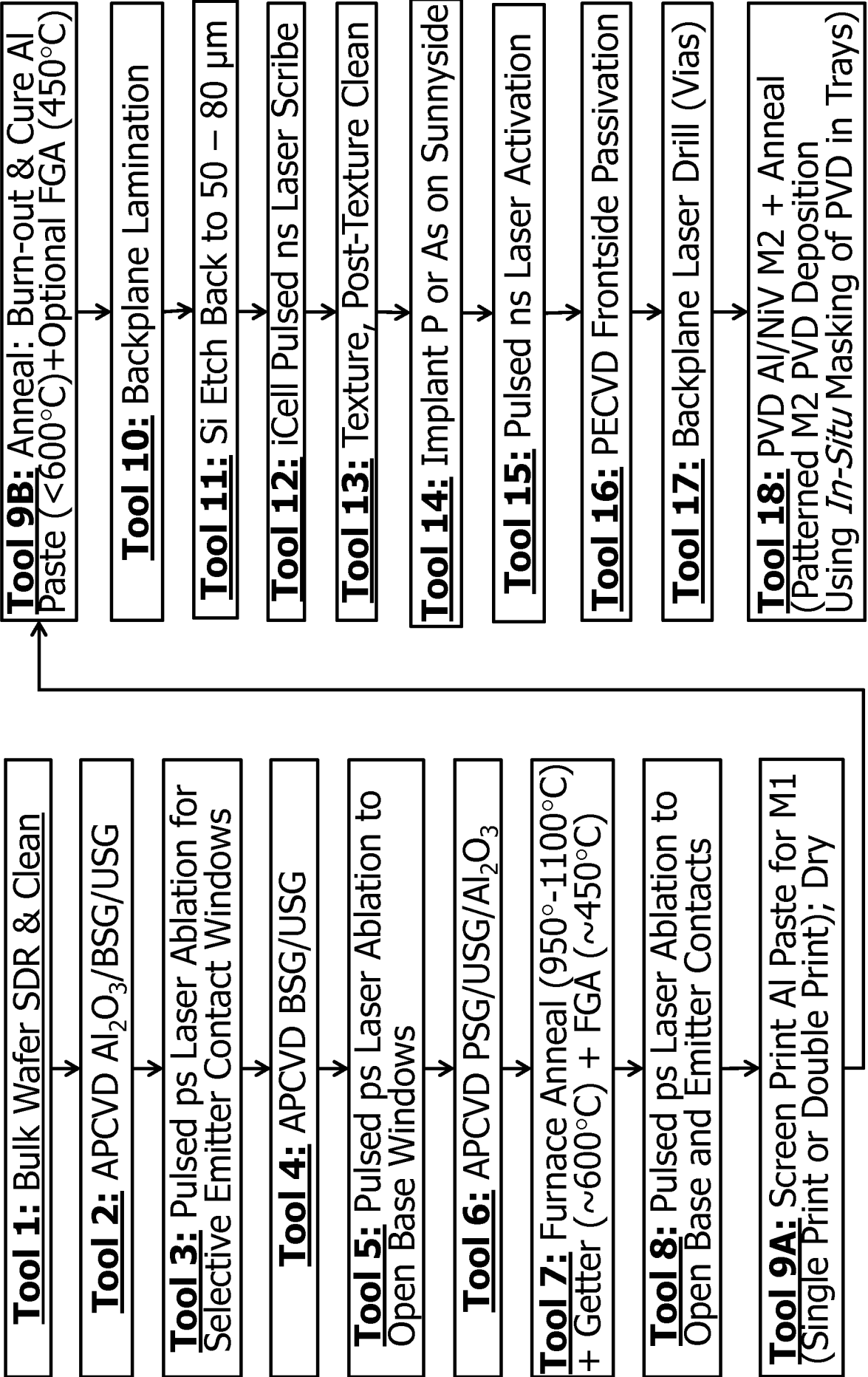


Fig. 40B

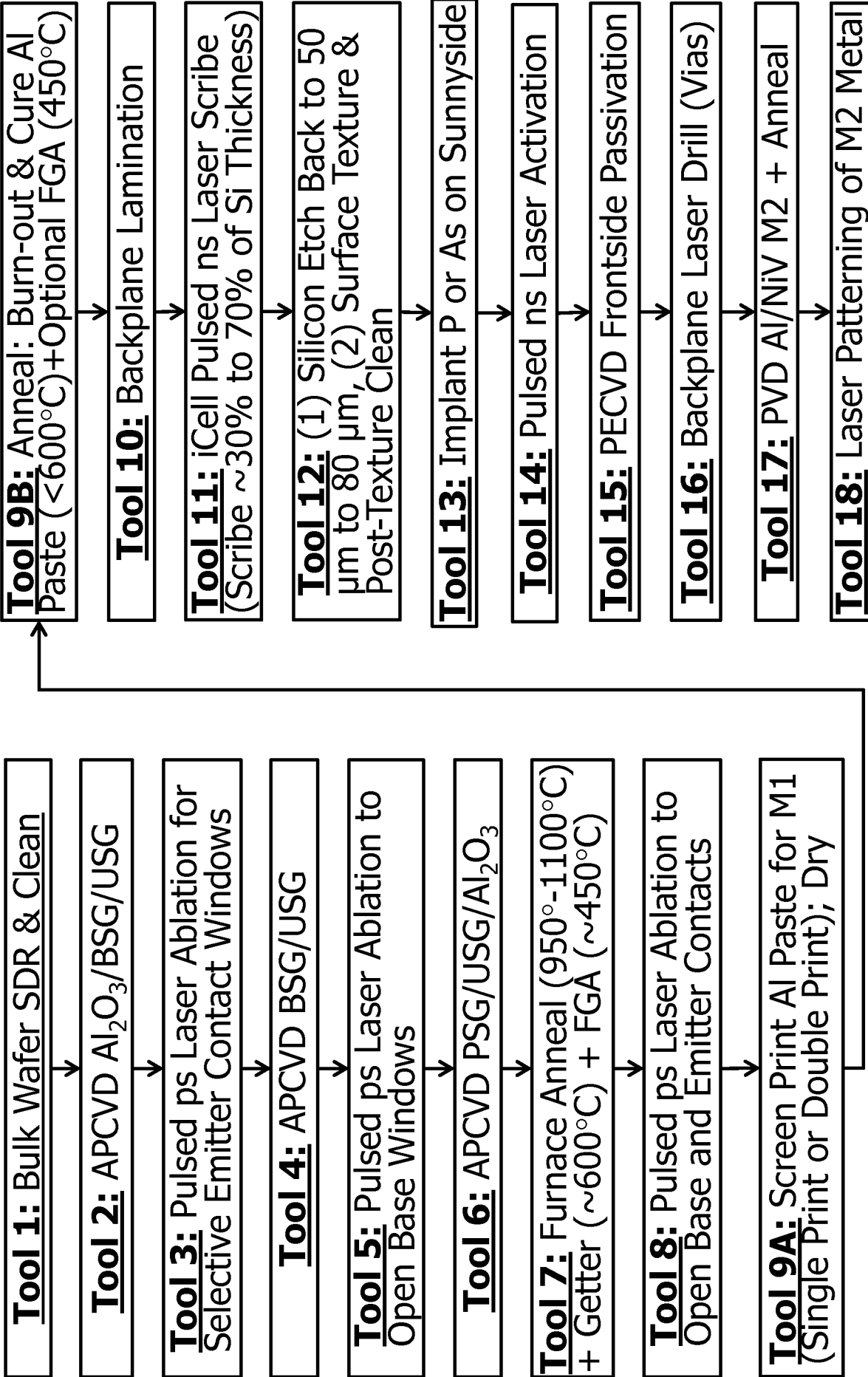


Fig. 40C

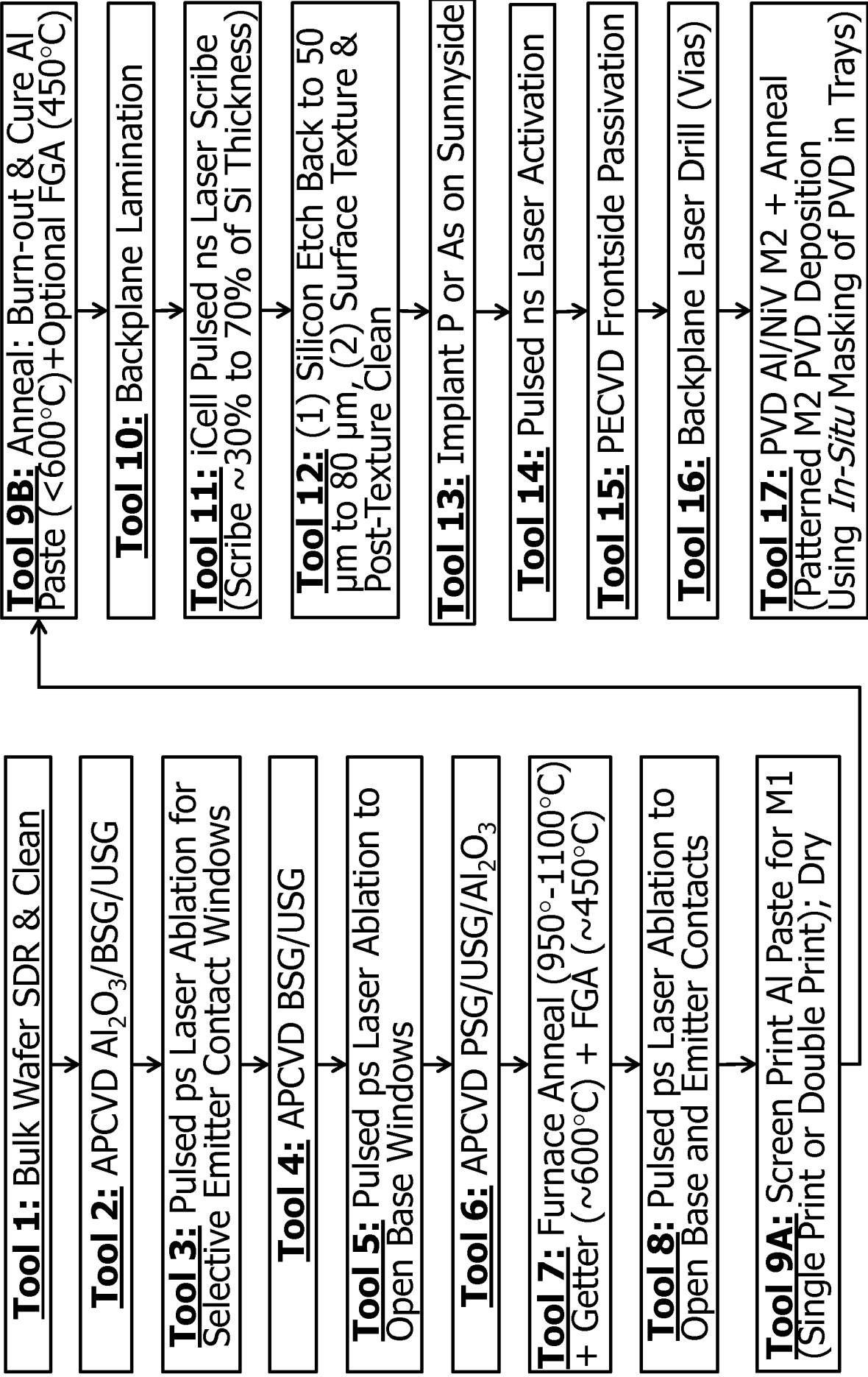


Fig. 40D

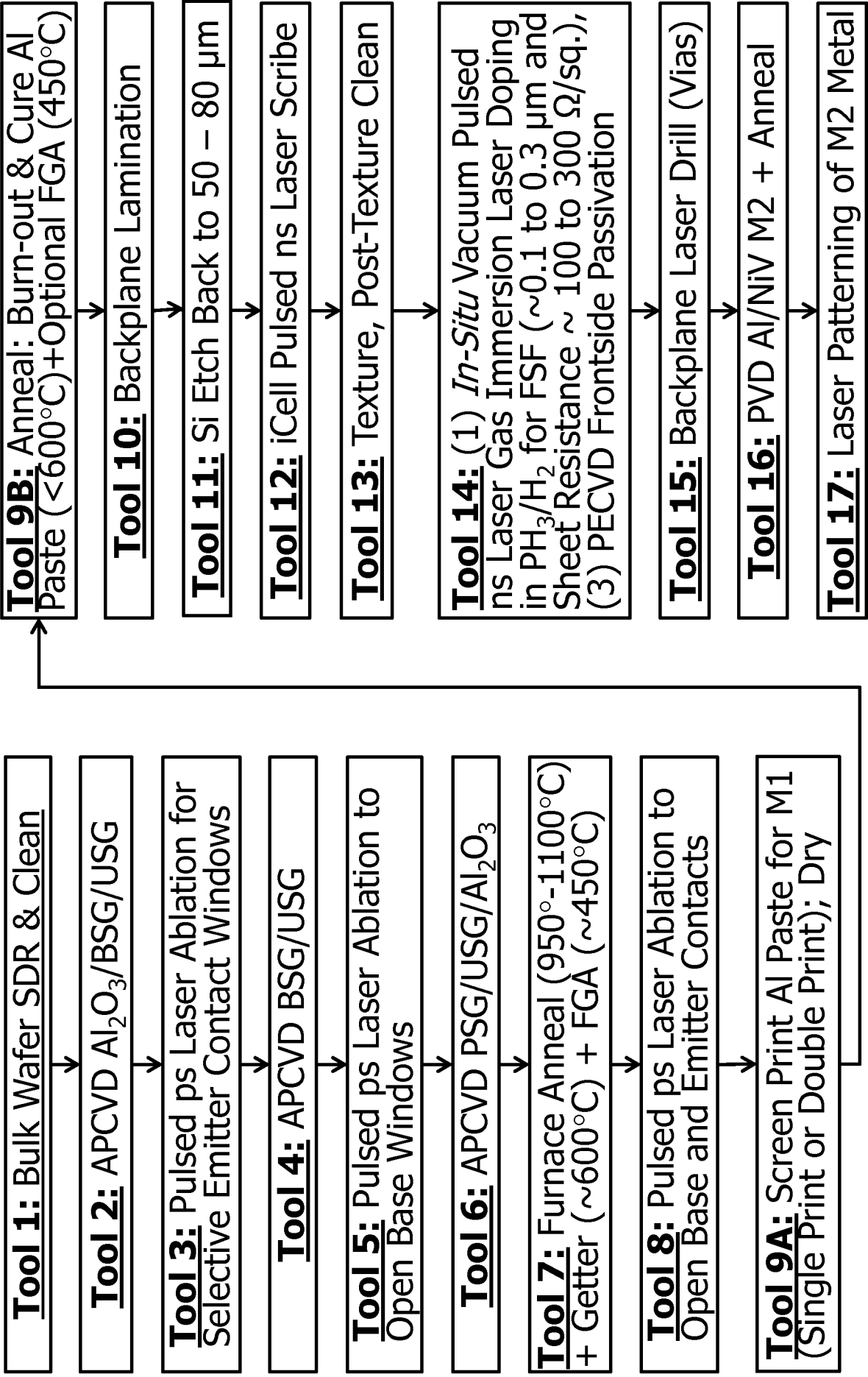


Fig. 41A

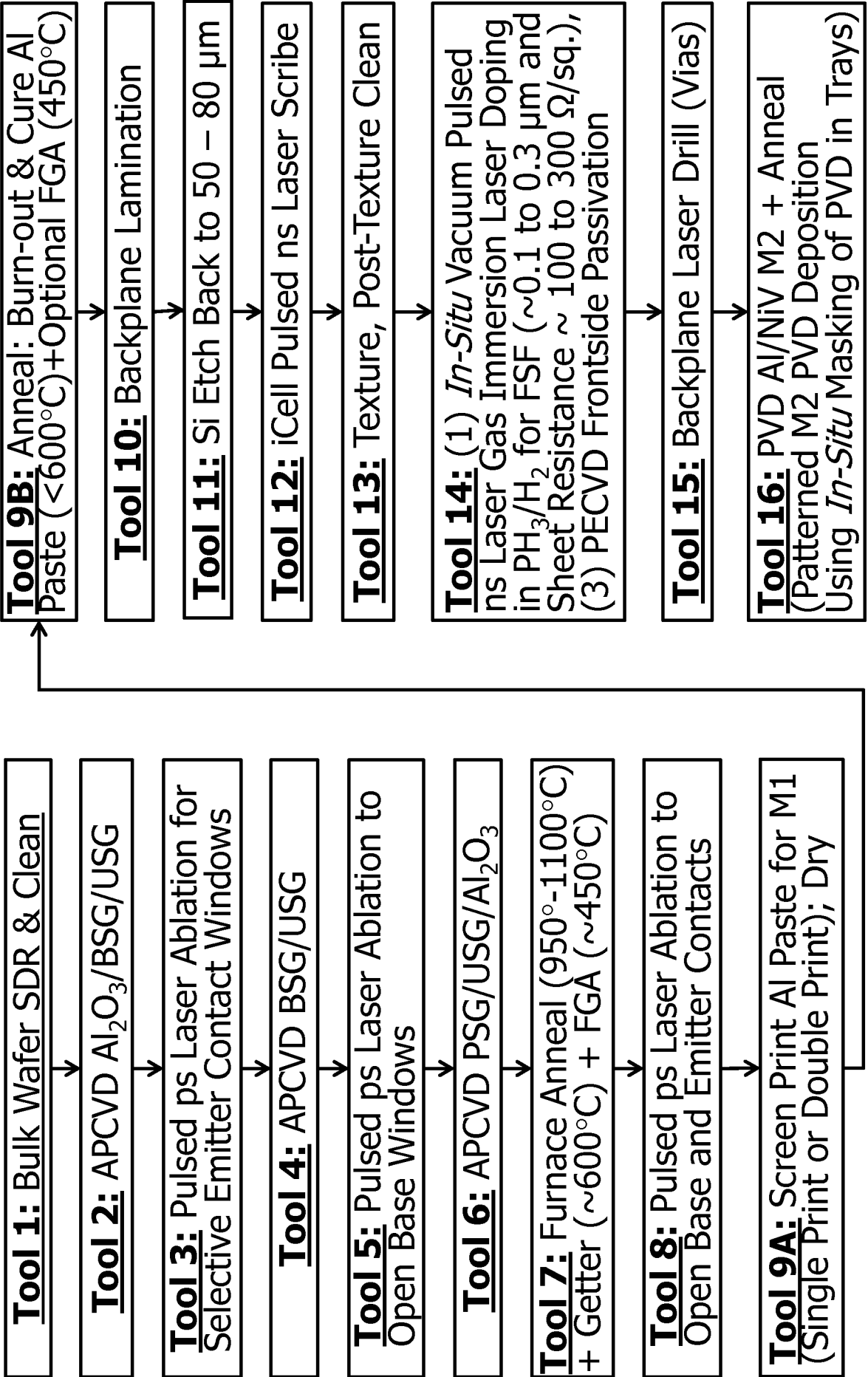


Fig. 41B

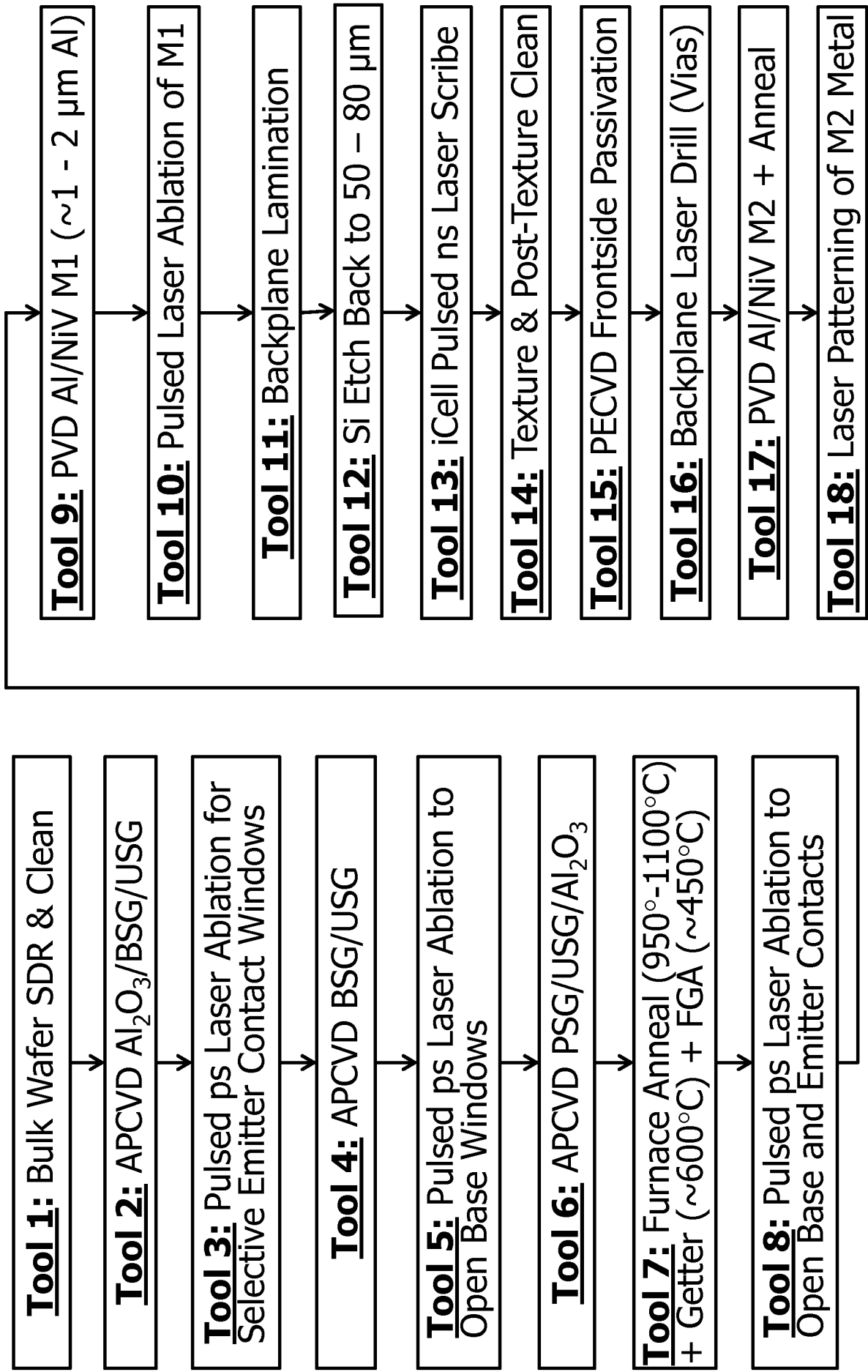


Fig. 42

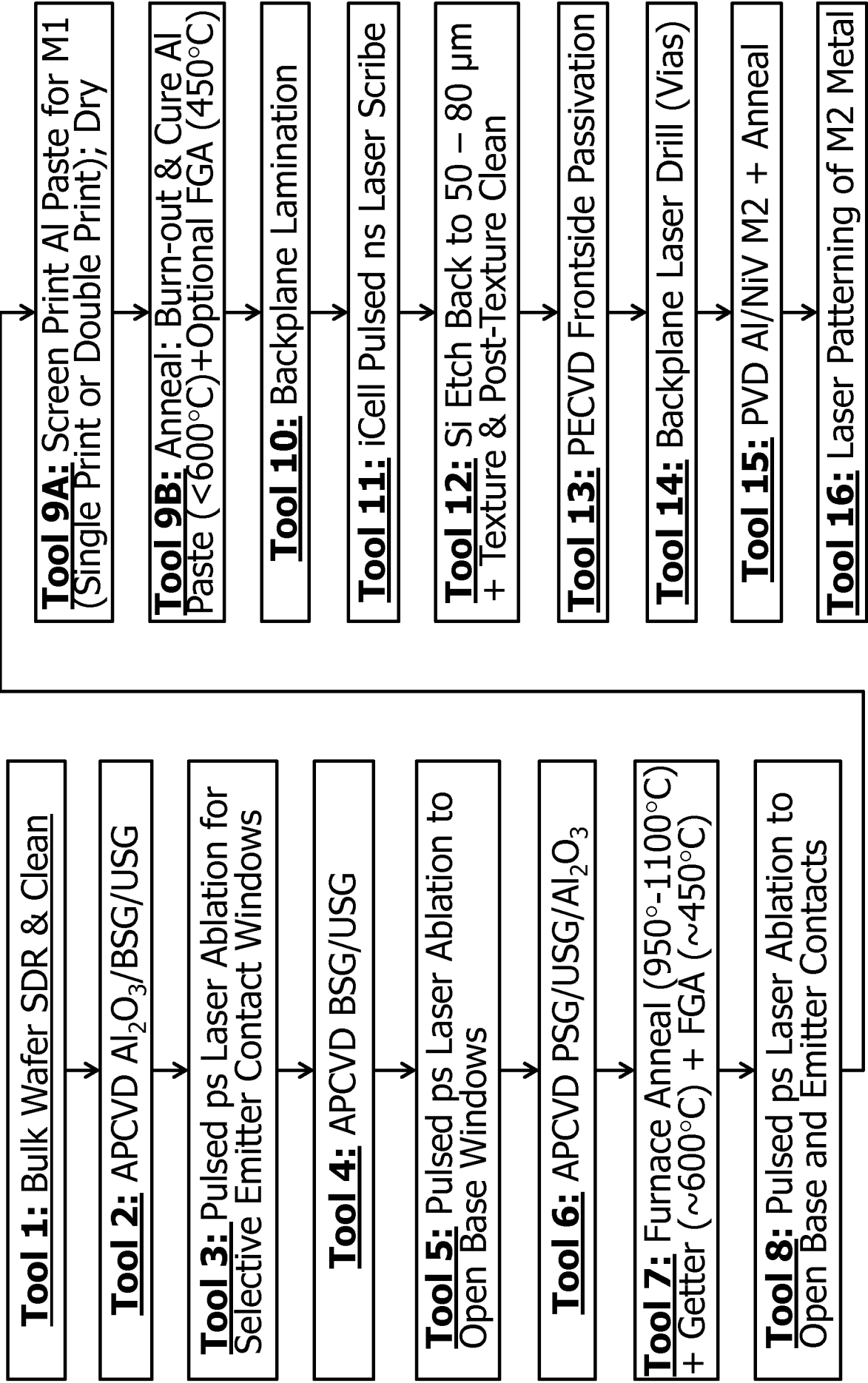


Fig. 43

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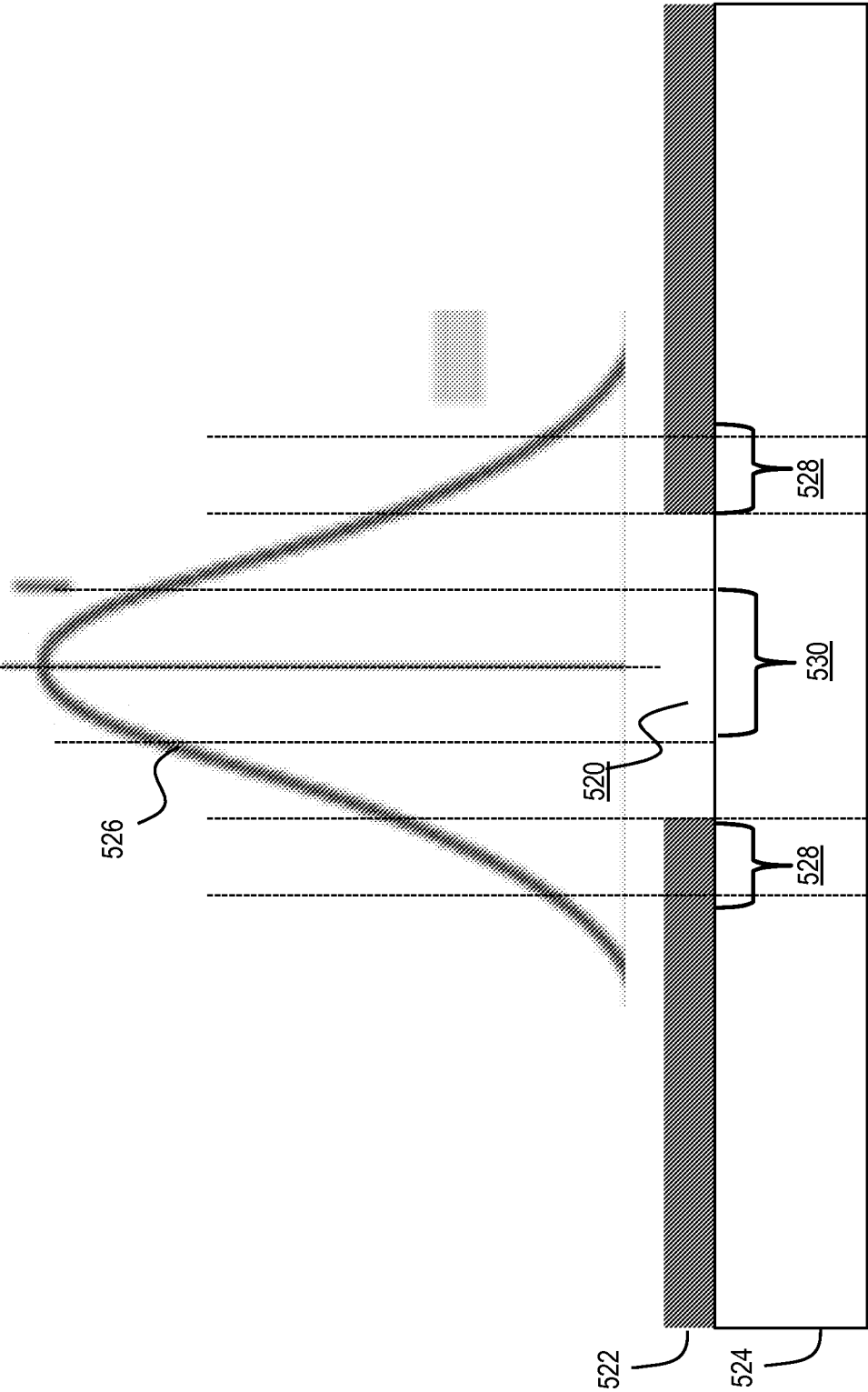


Fig. 44A

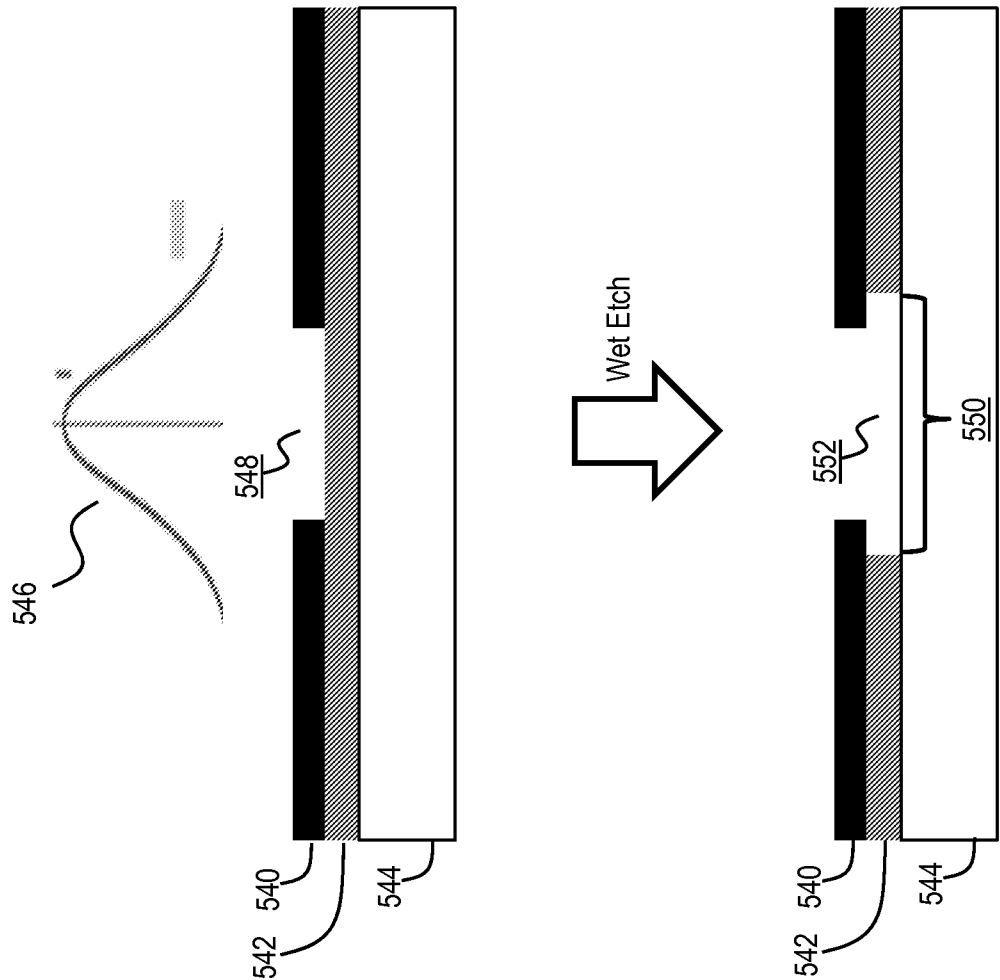


Fig. 44B

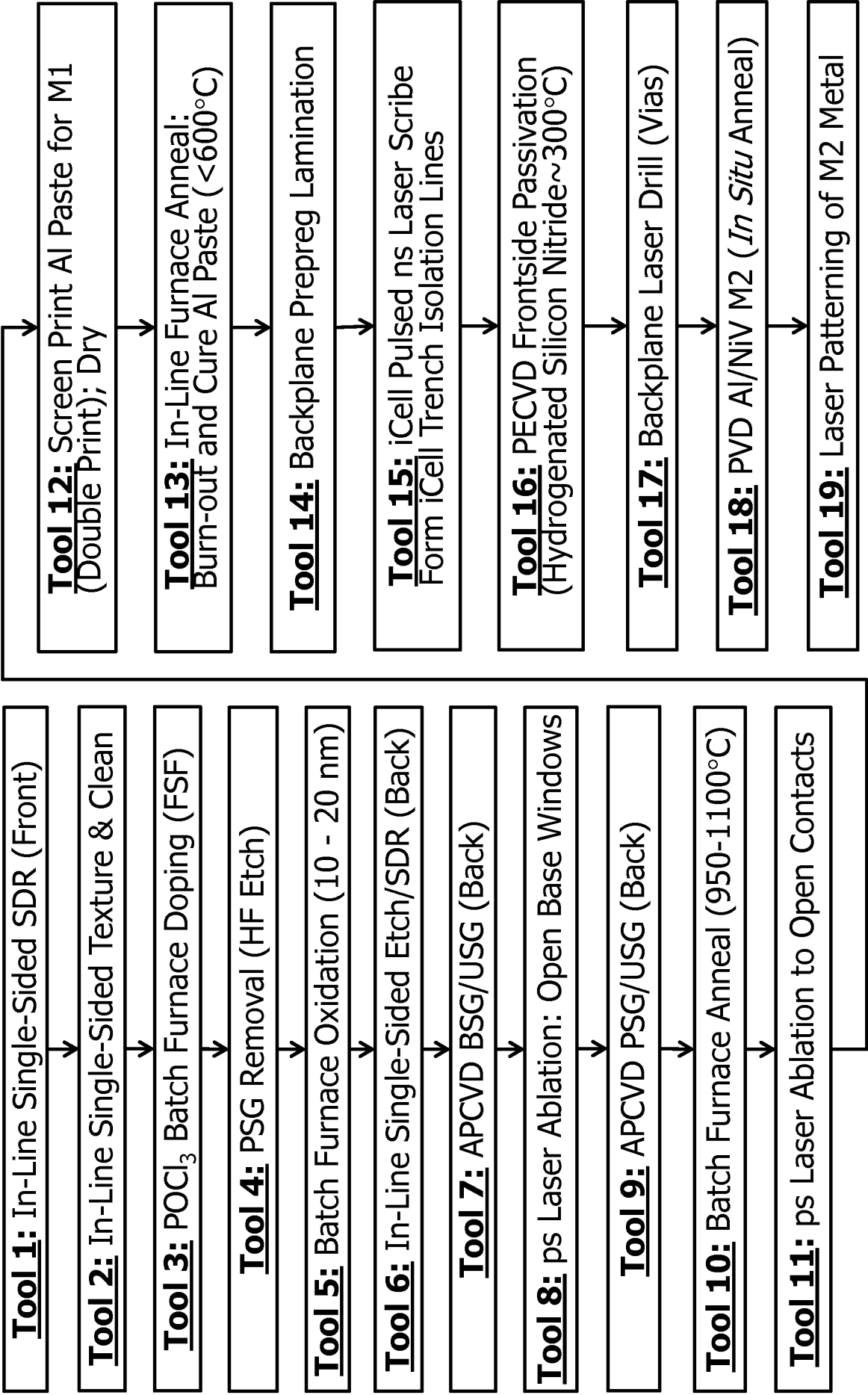


Fig. 45

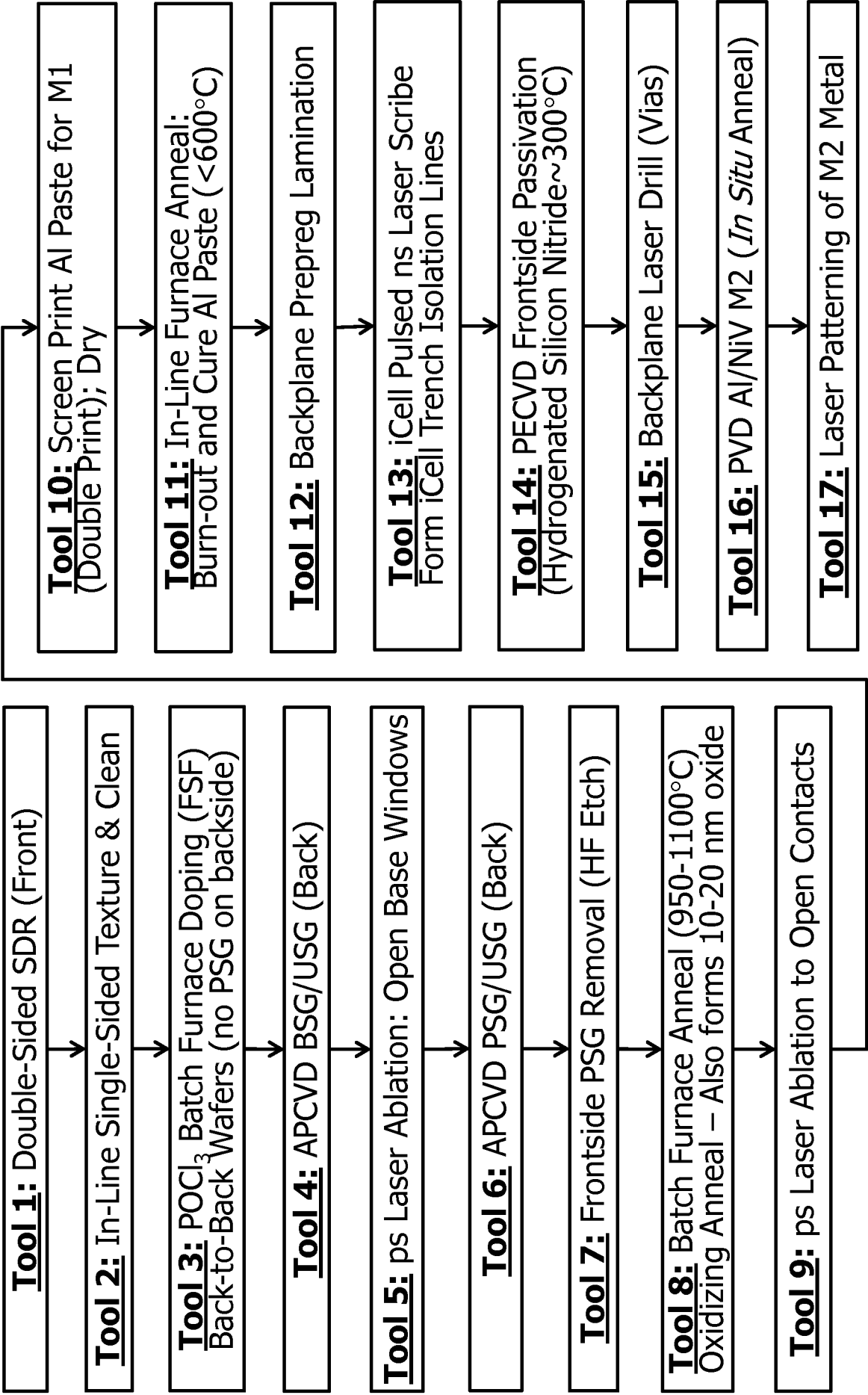


Fig. 46

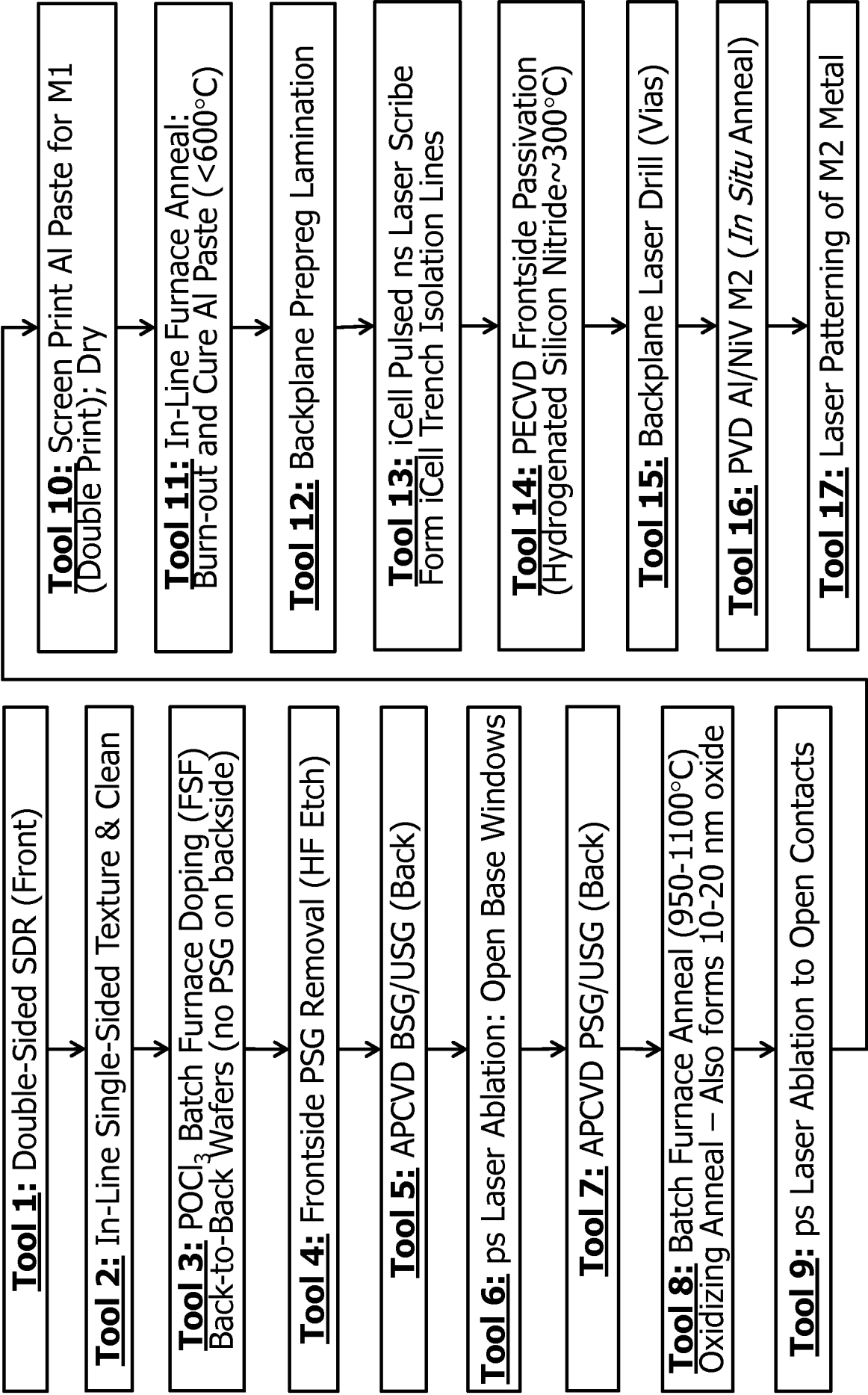


Fig. 47

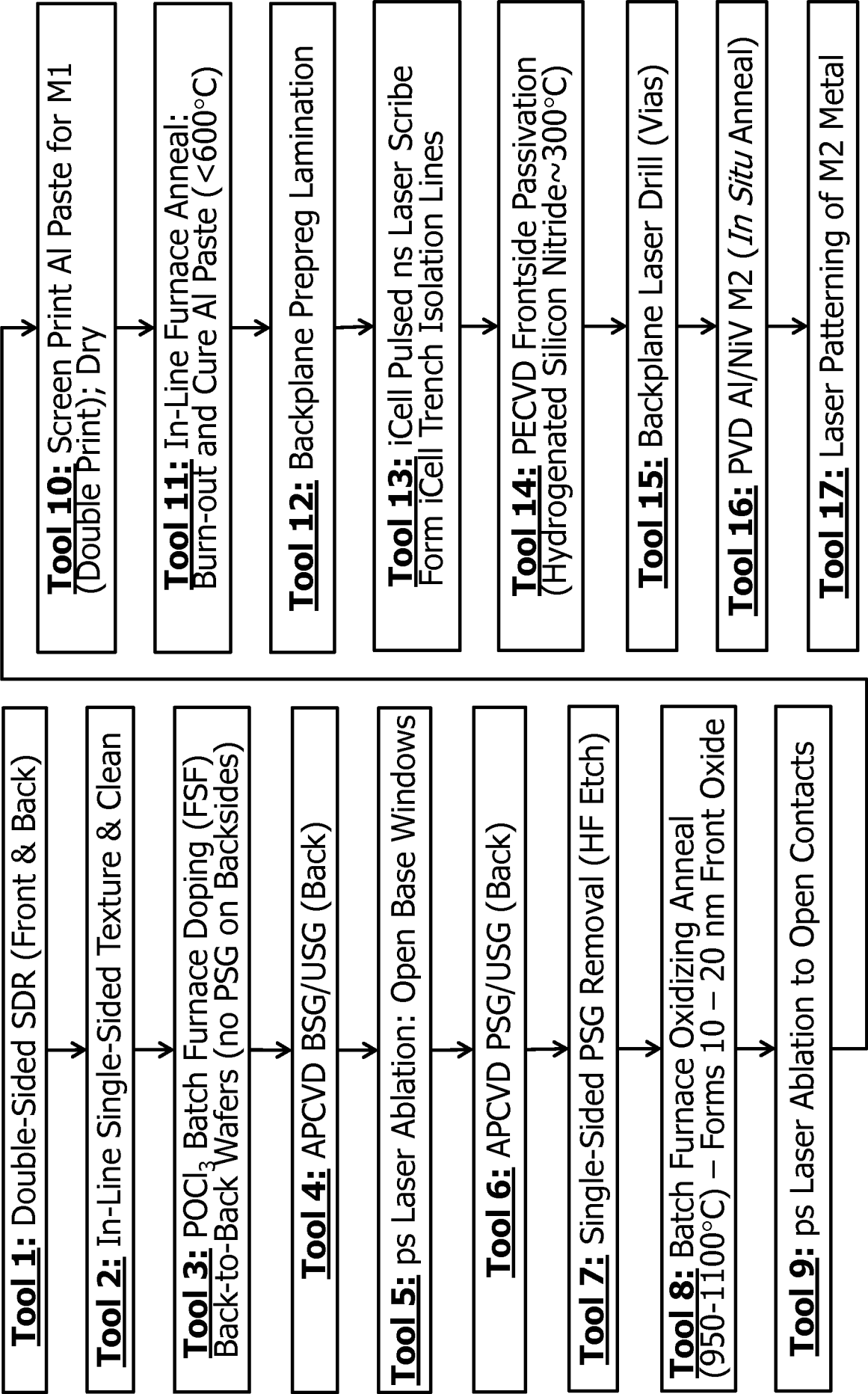


Fig. 48

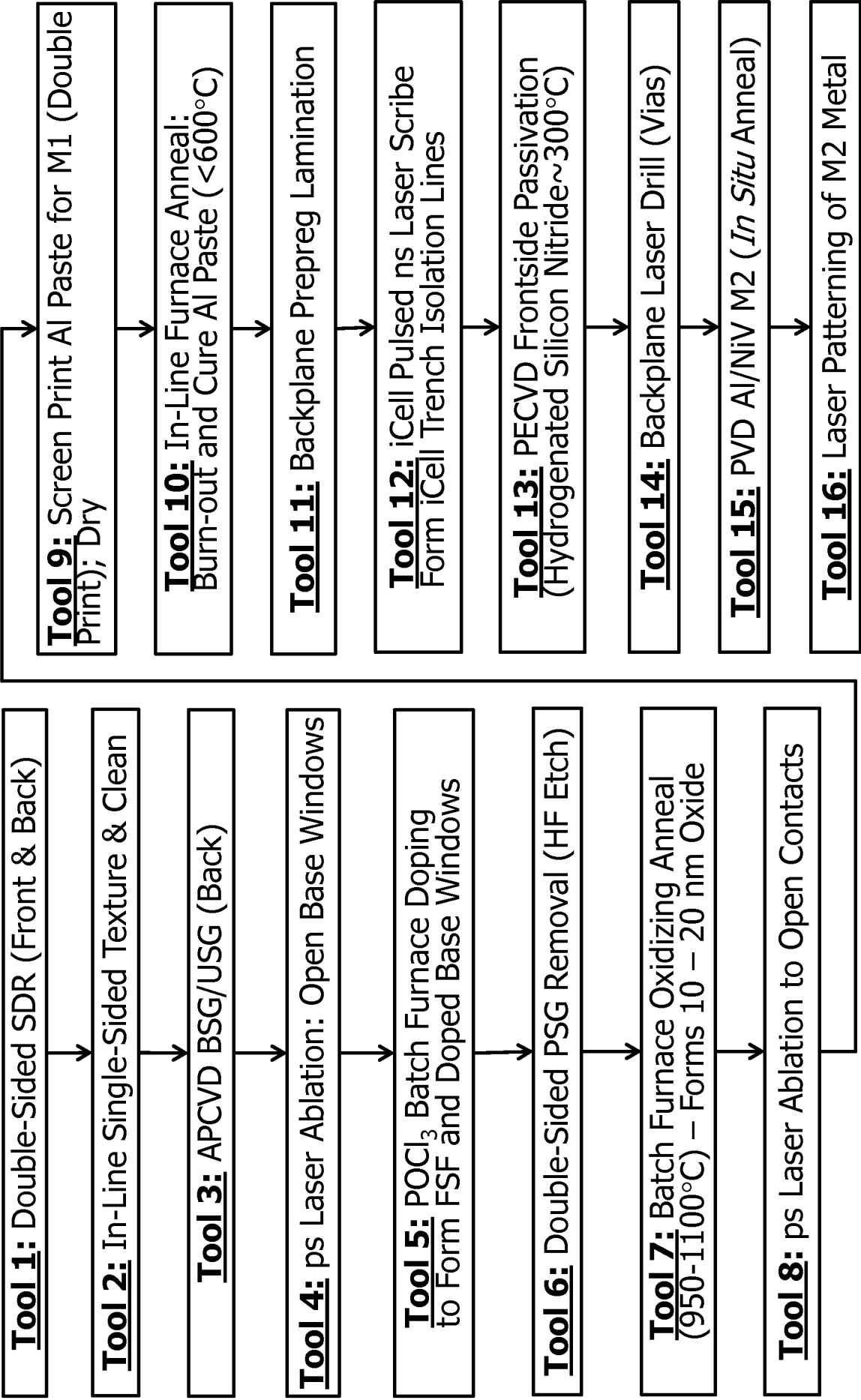


Fig. 49

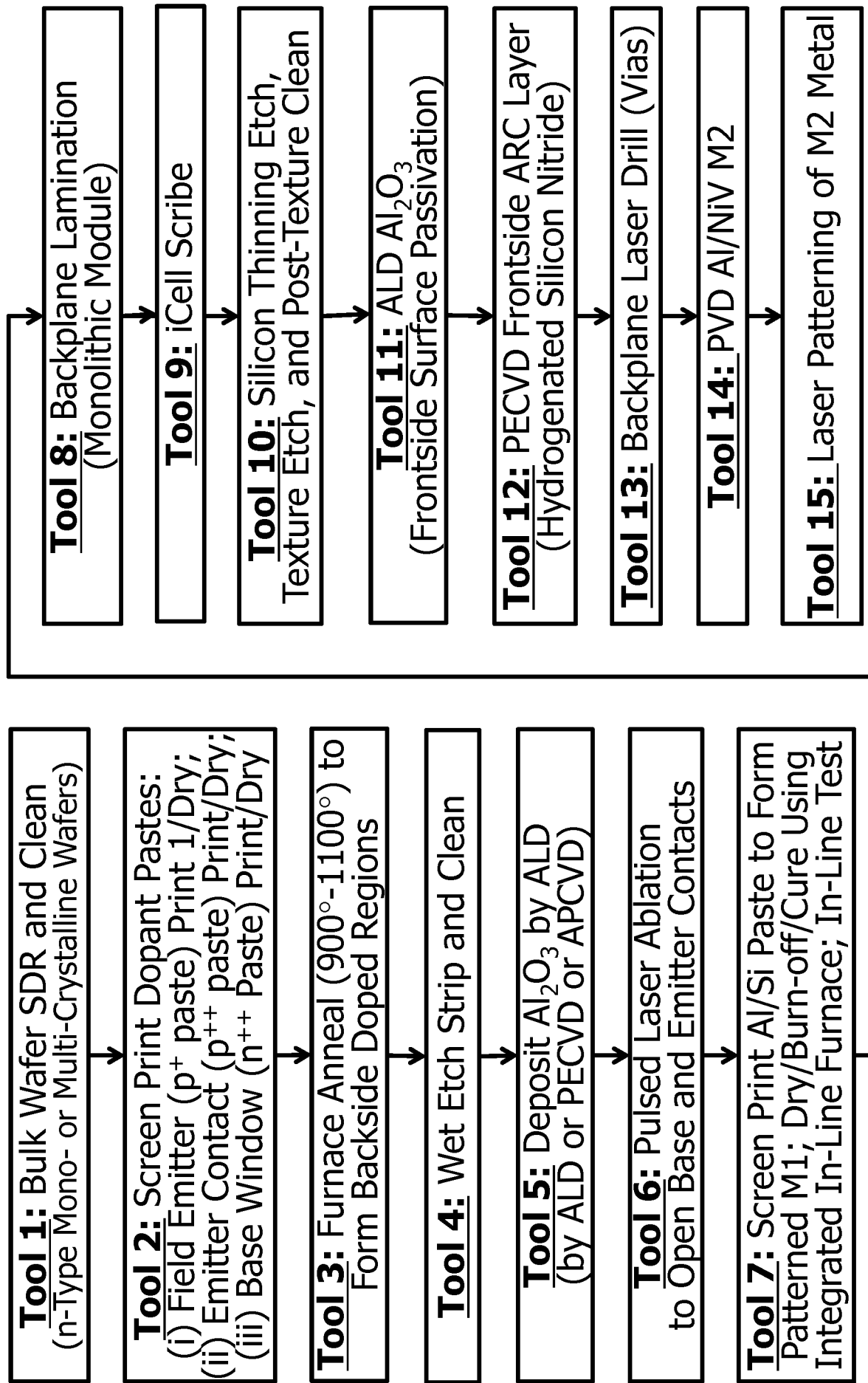


Fig. 50A

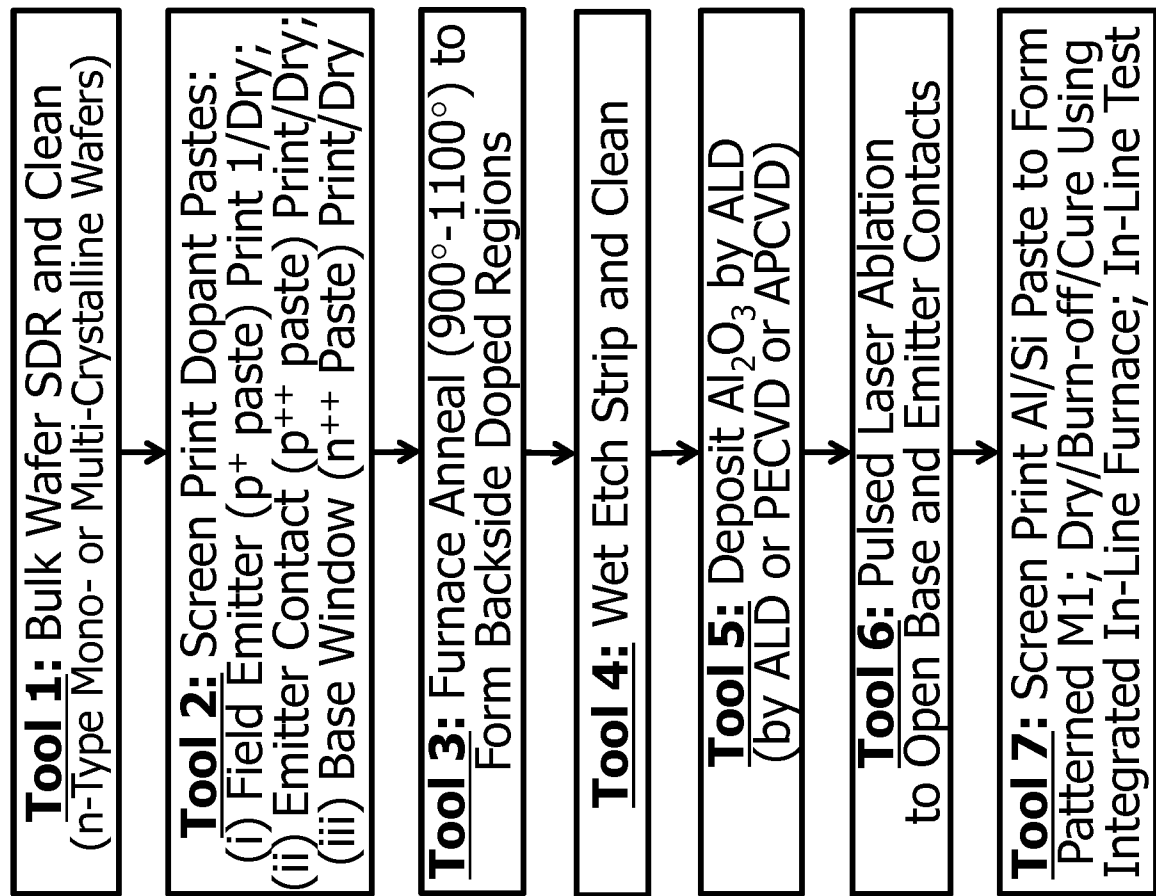
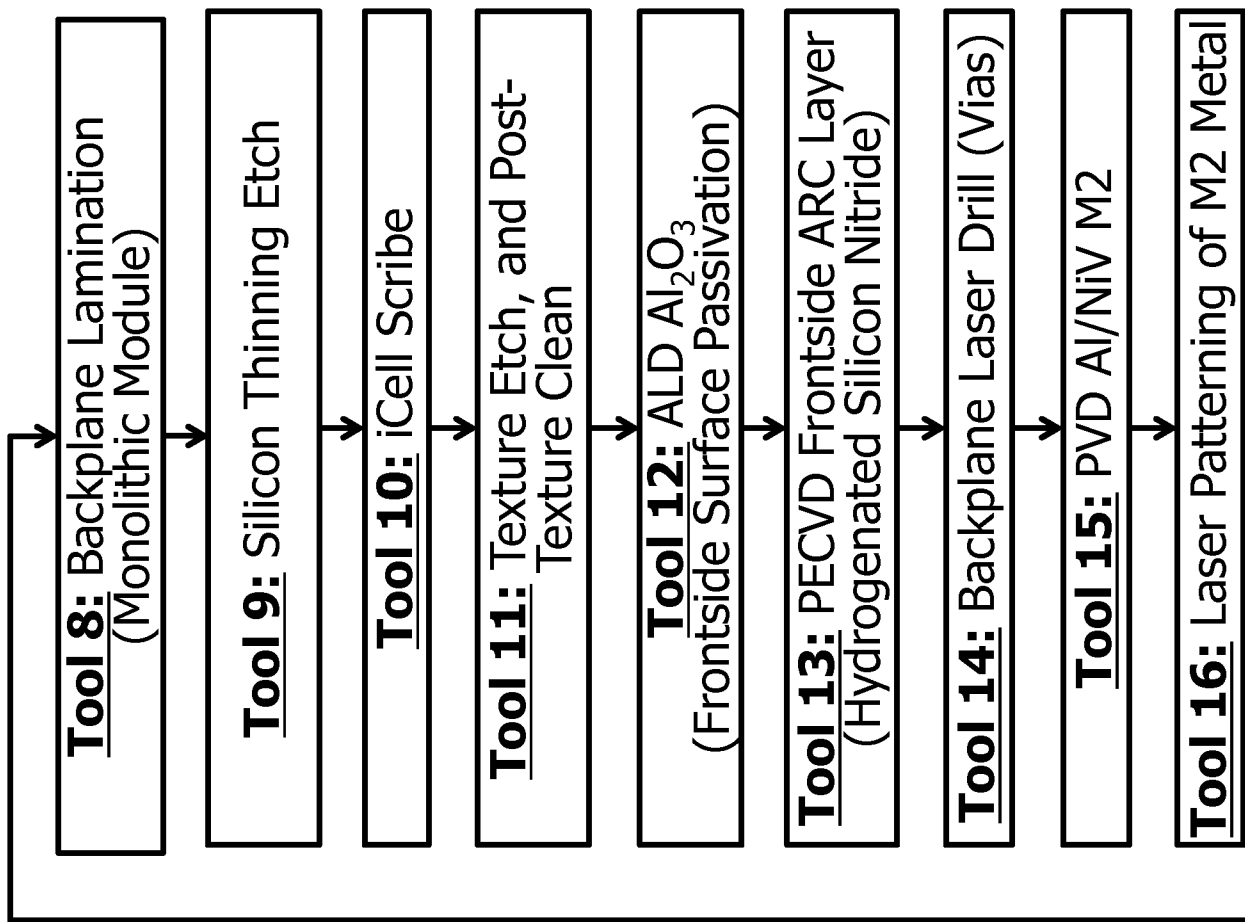


Fig. 50B

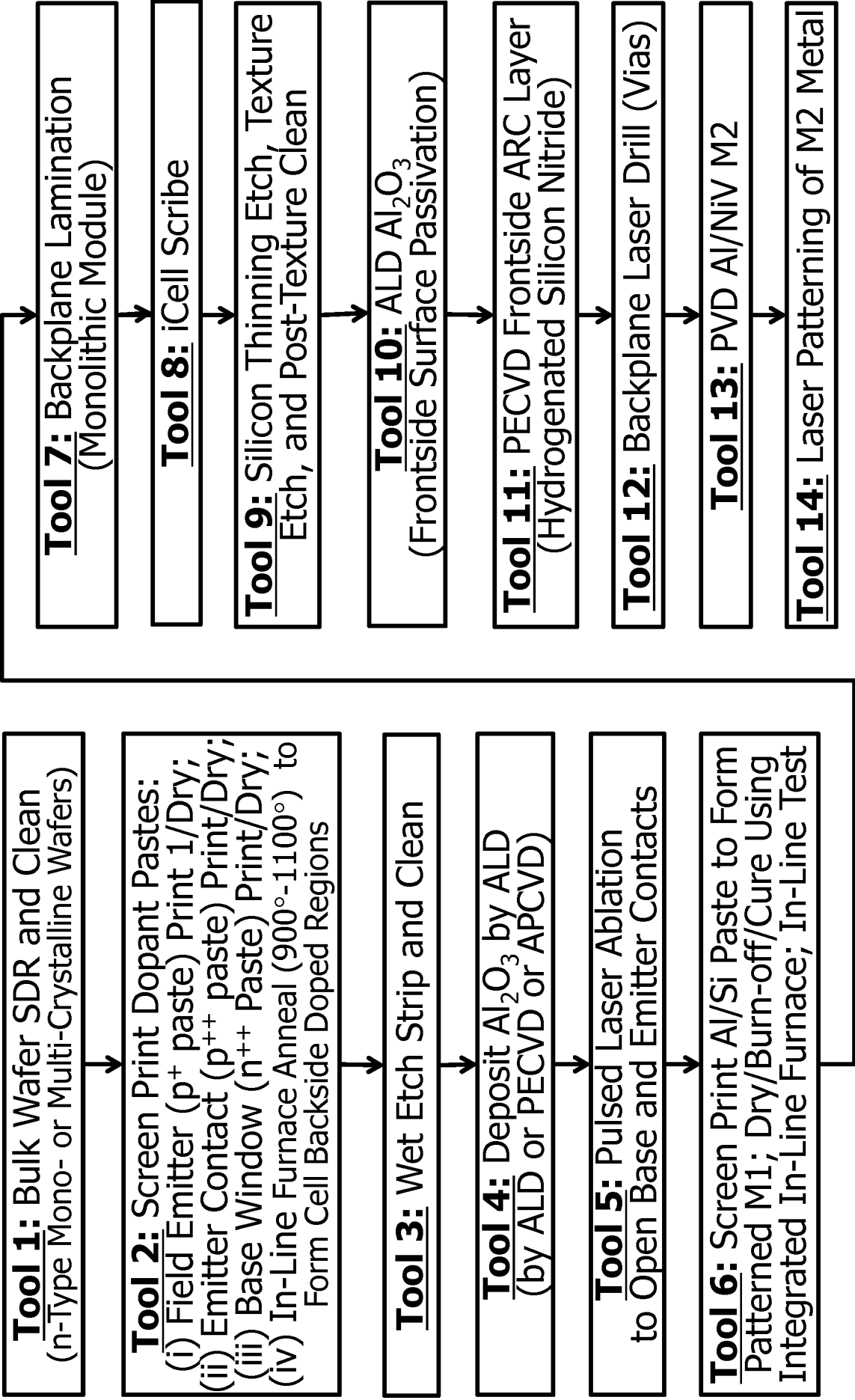


Fig. 51A

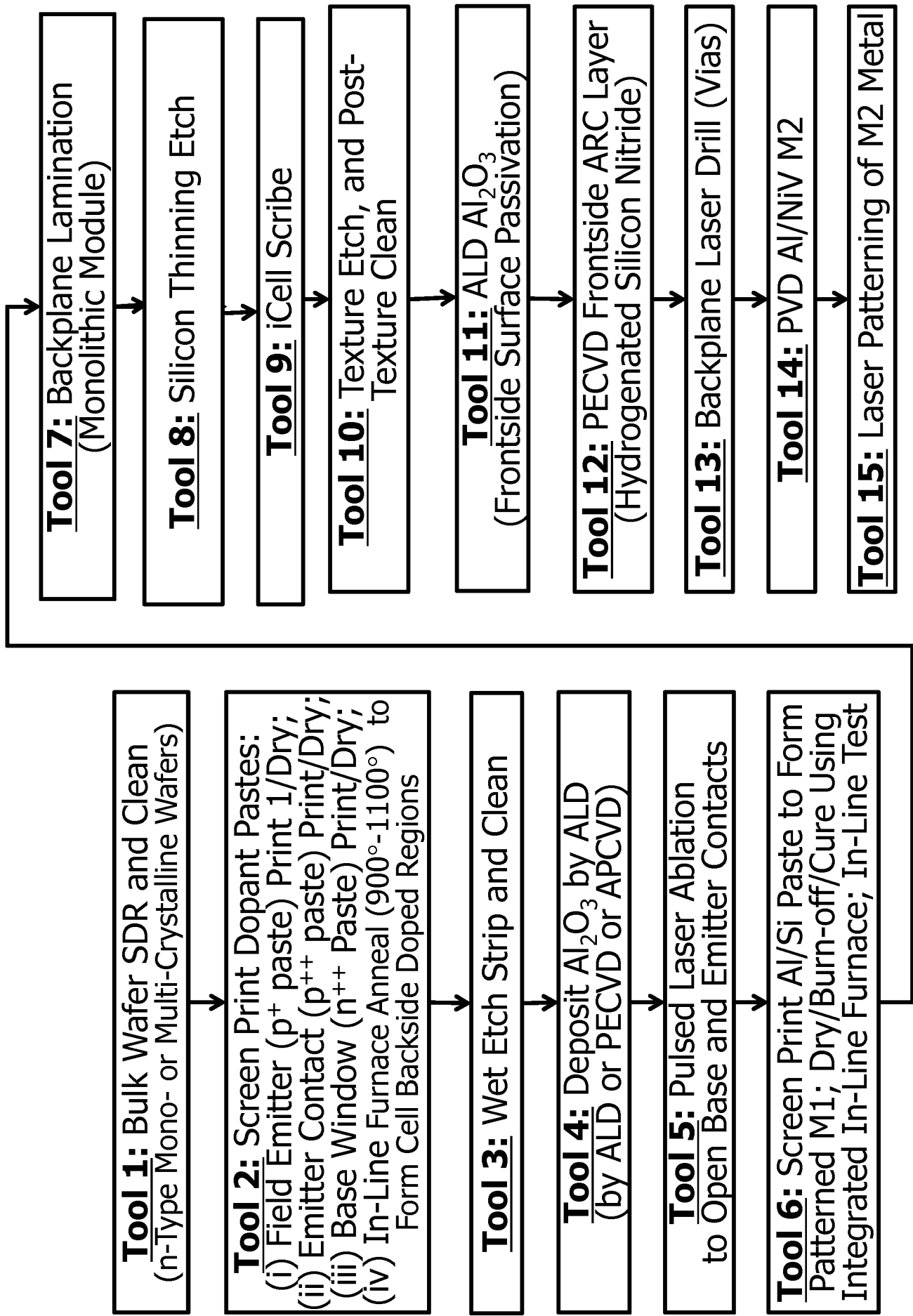


Fig. 51B

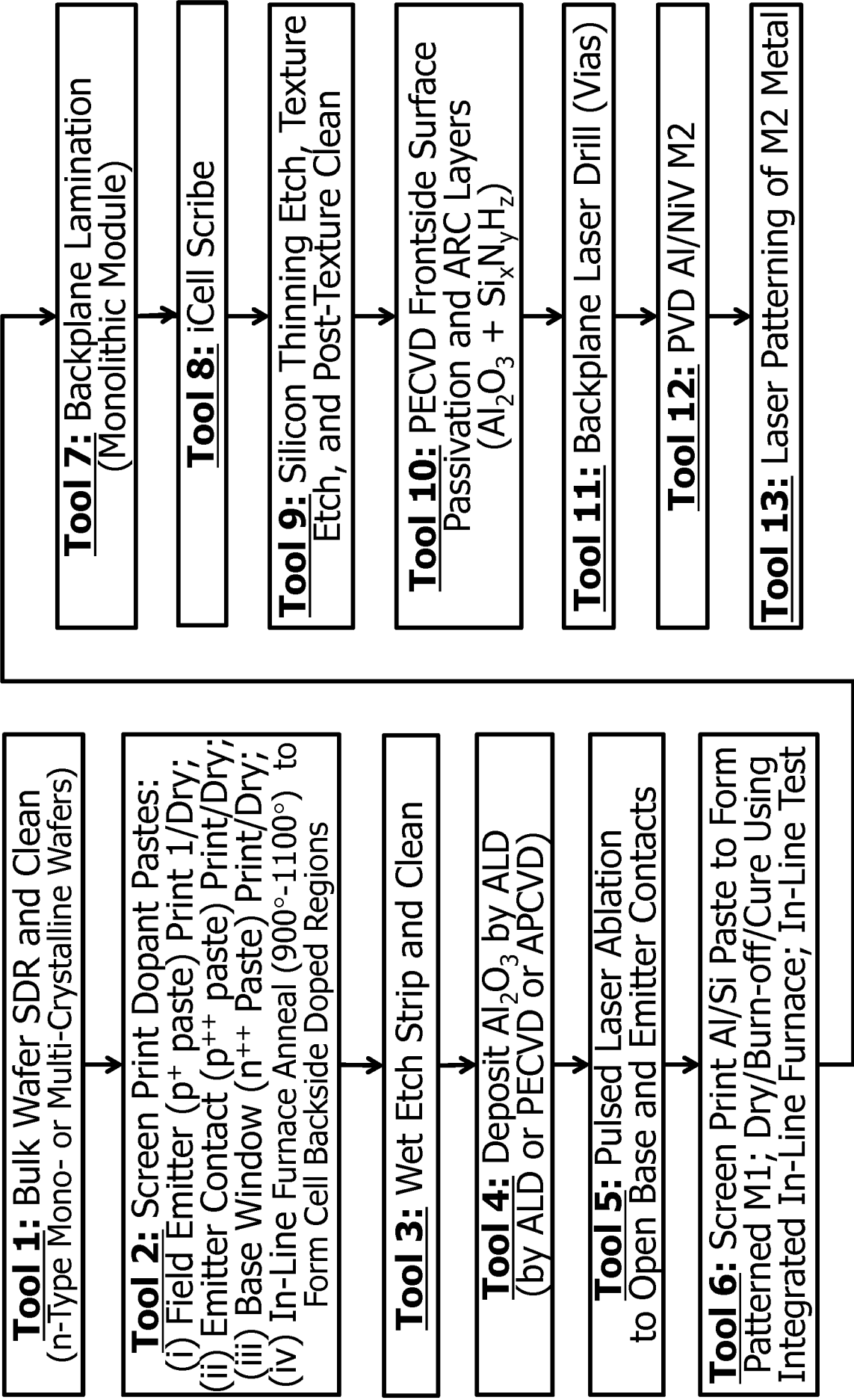


Fig. 52A

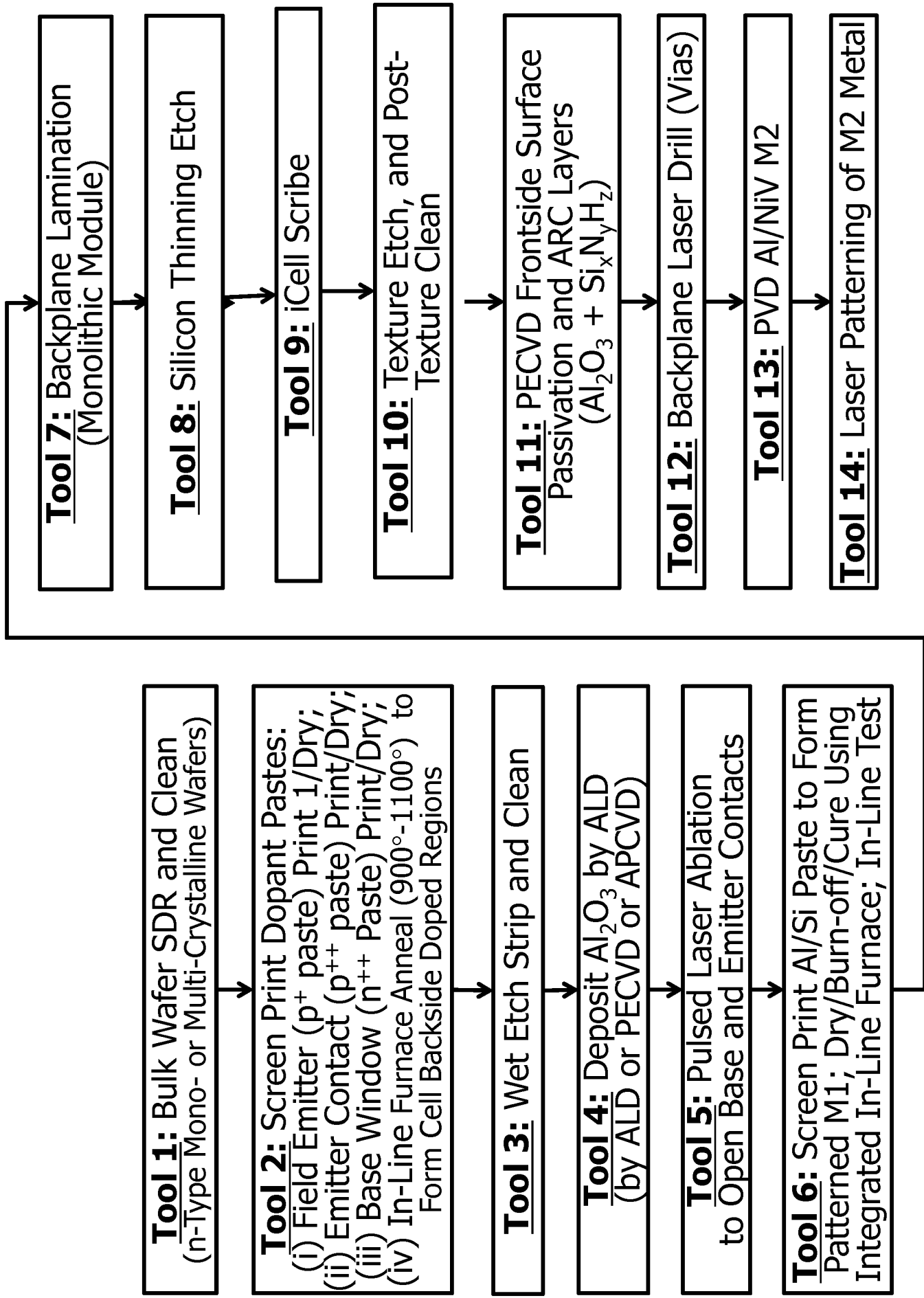


Fig. 52B

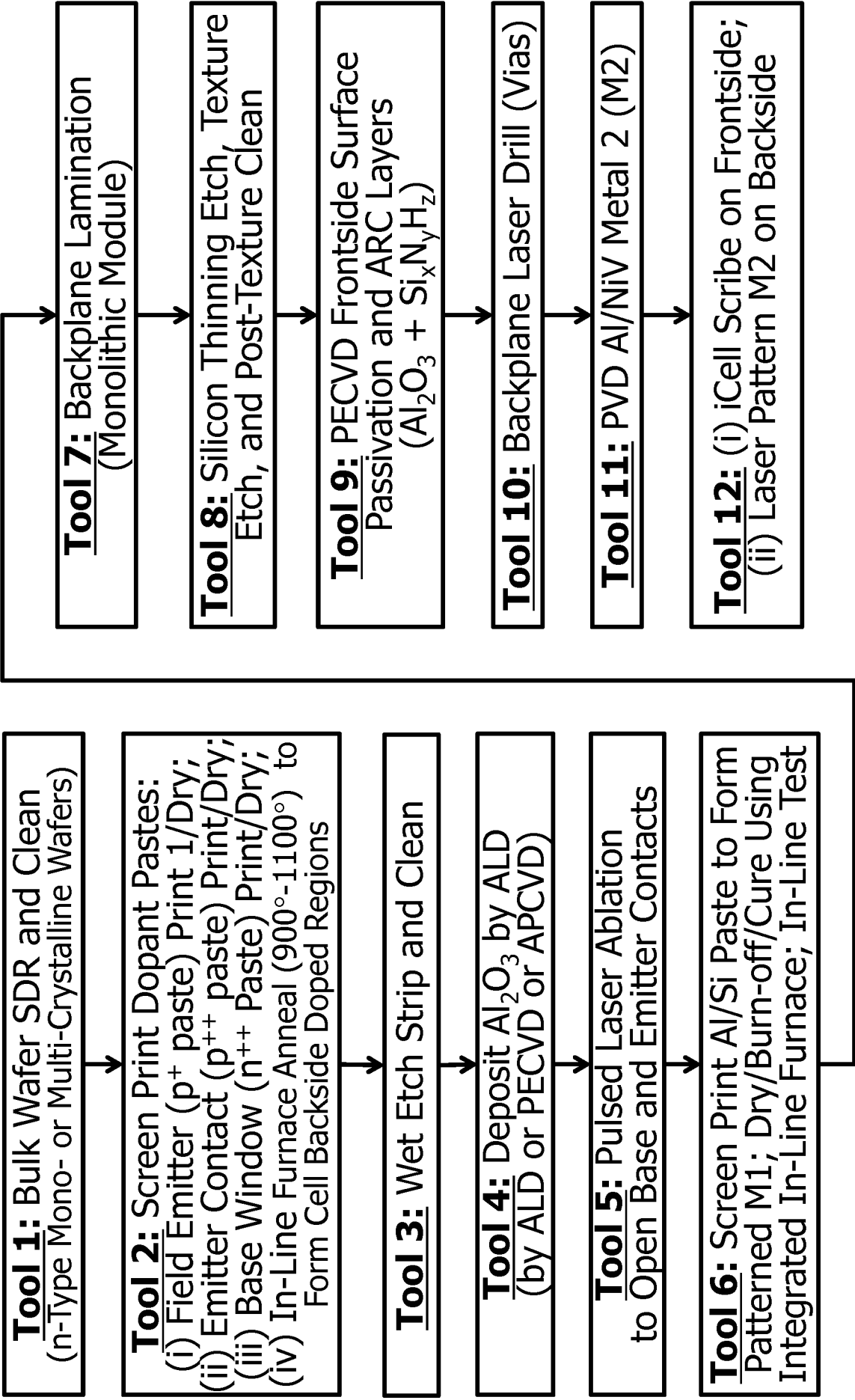


Fig. 53

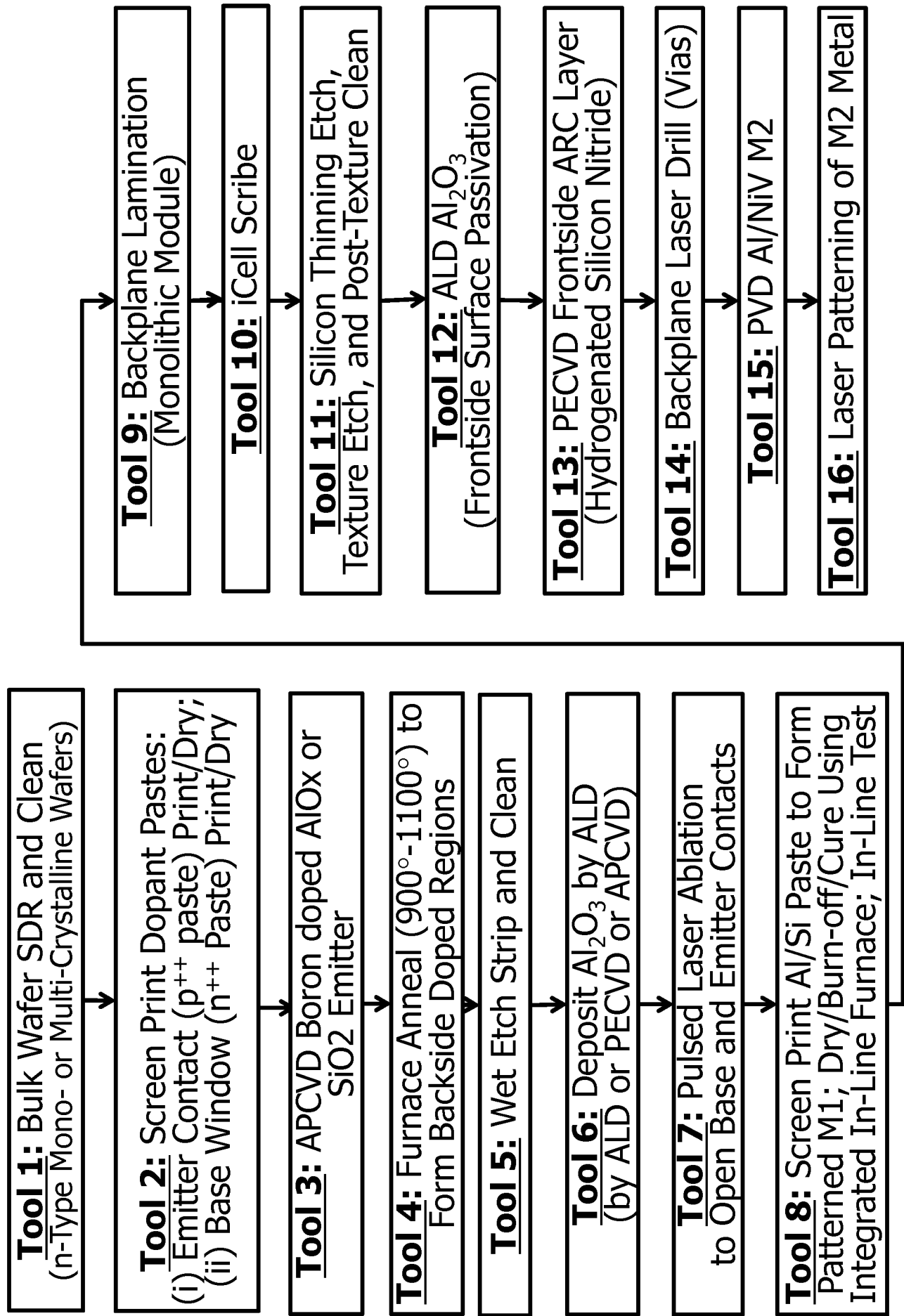


Fig. 54A

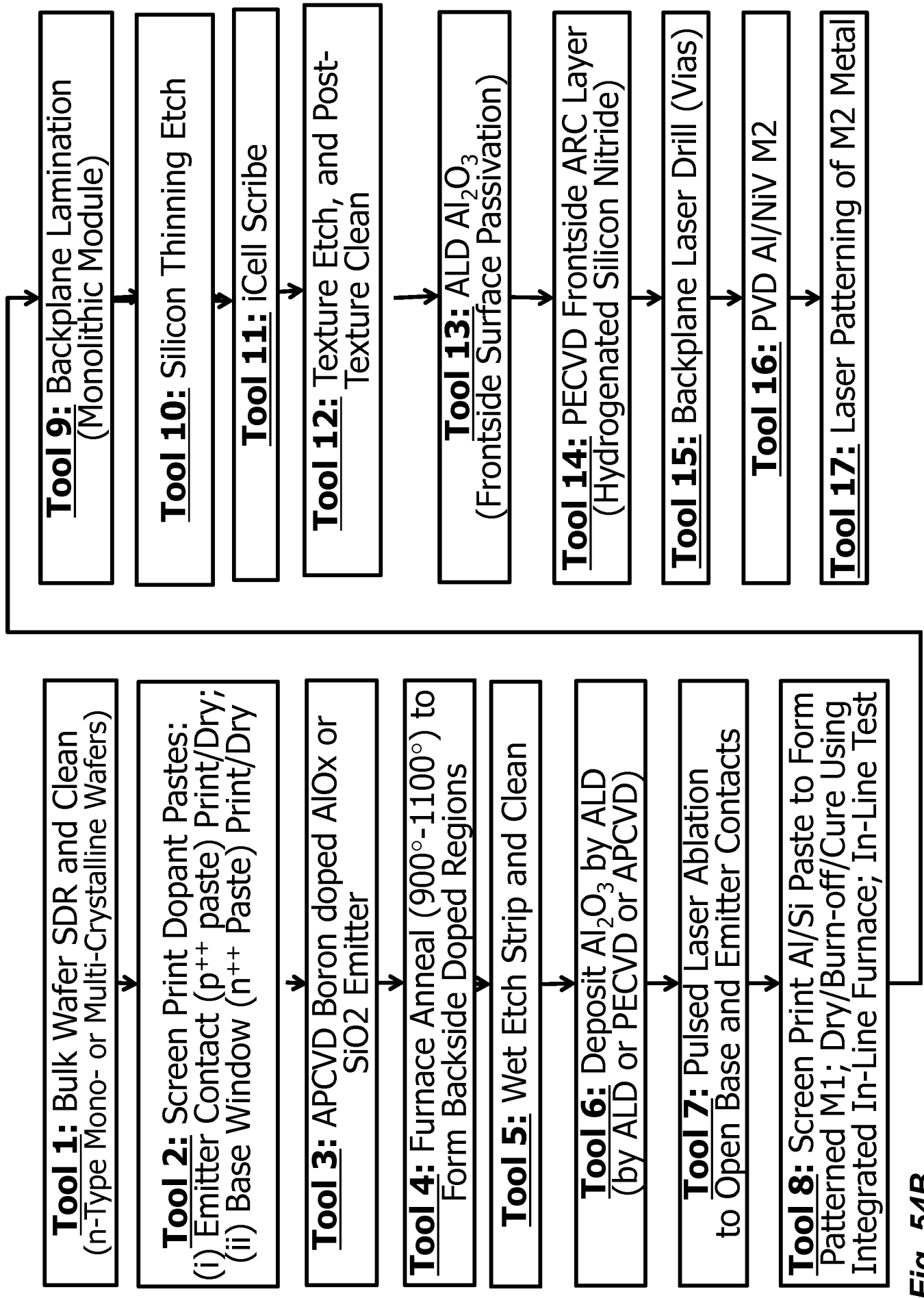


Fig. 54B

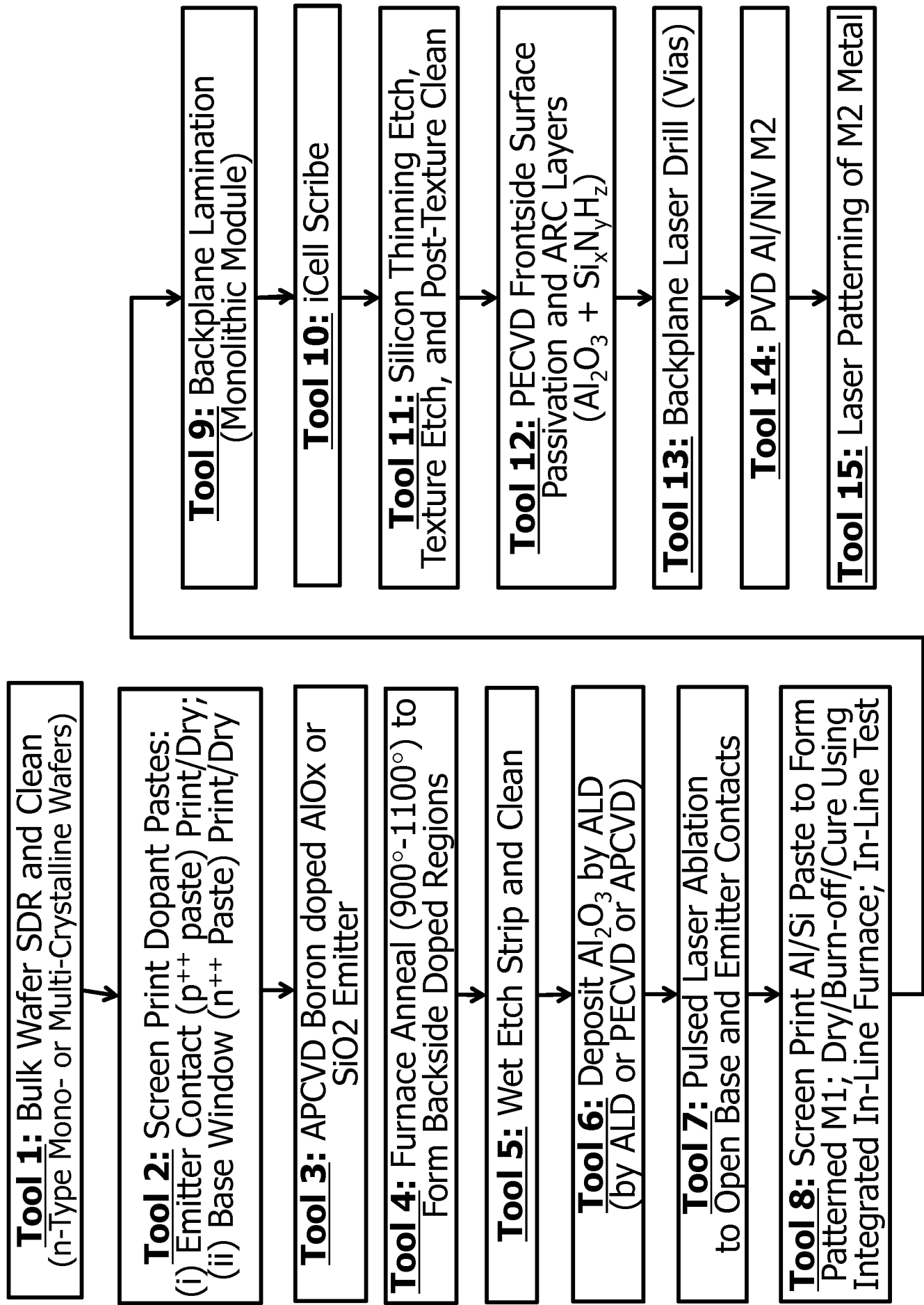


Fig. 55A

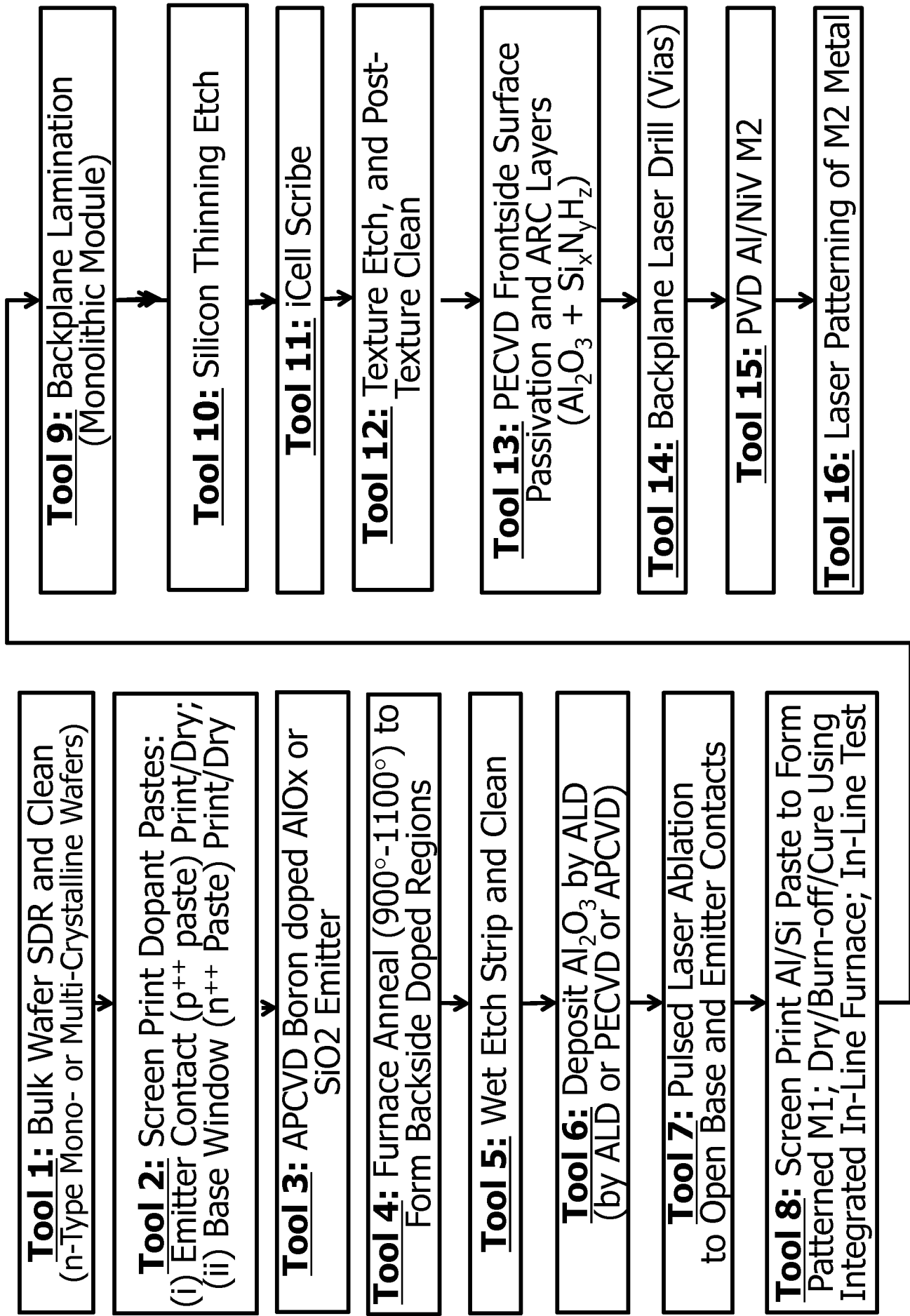


Fig. 55B

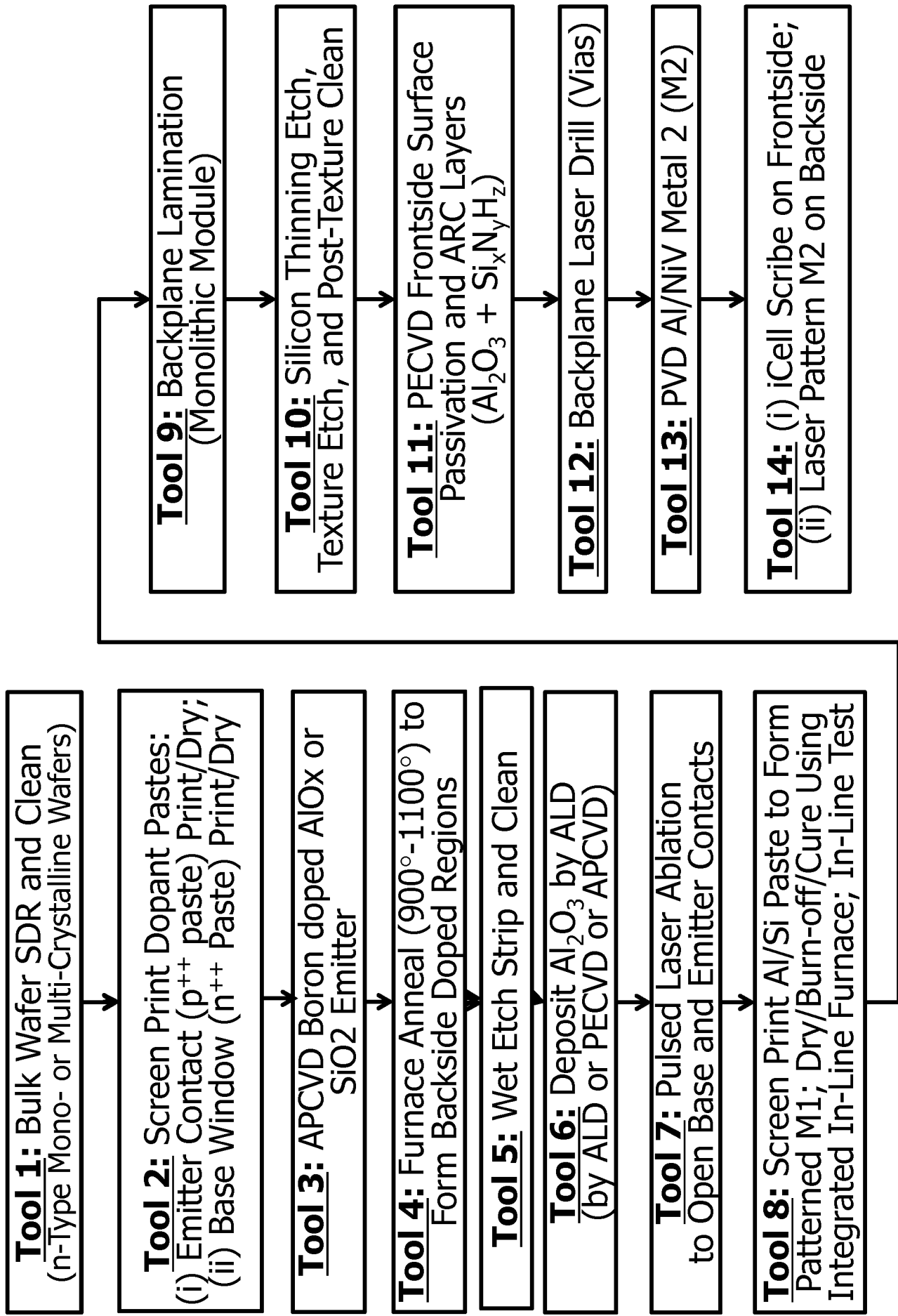


Fig. 56A

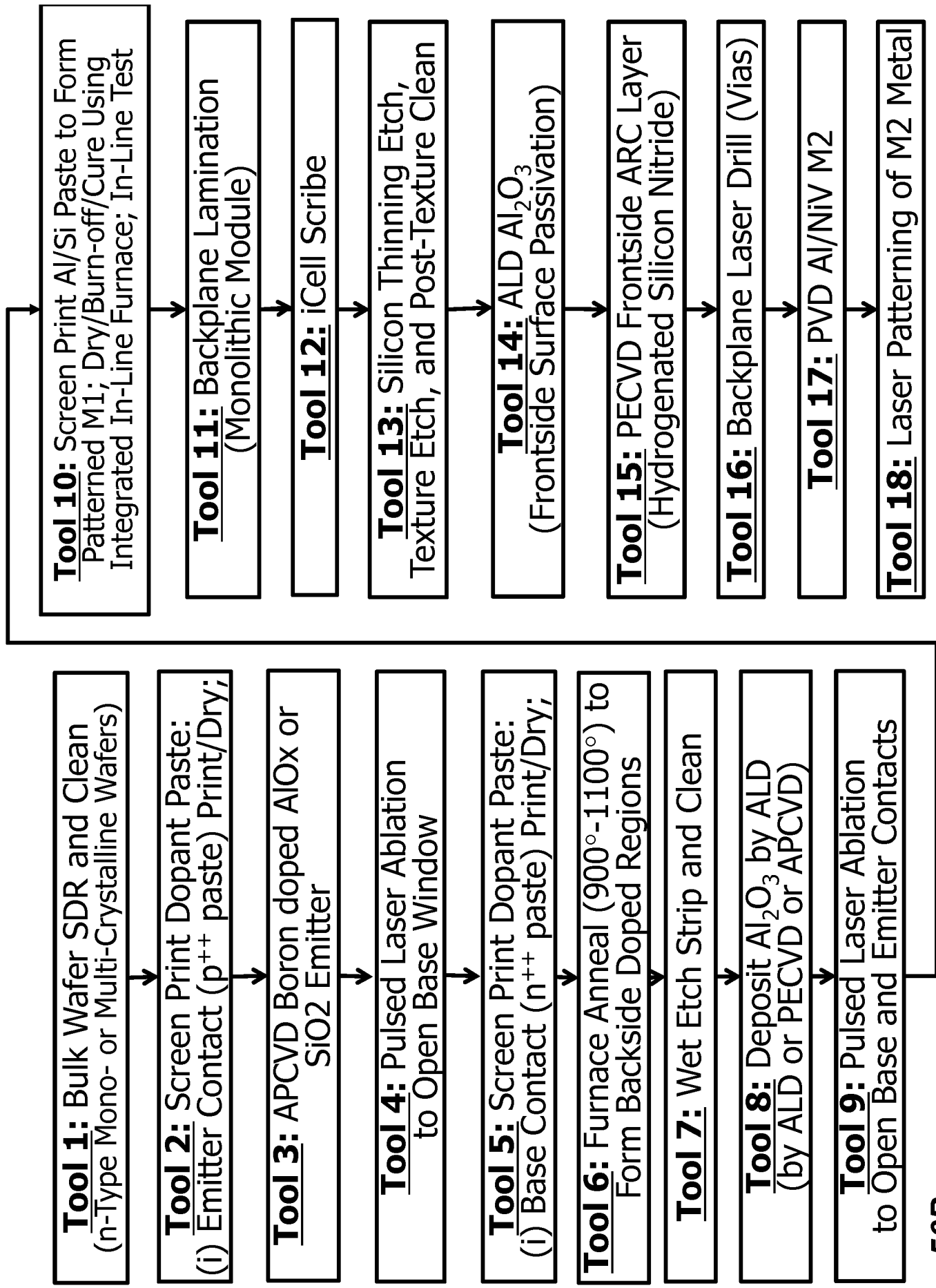


Fig. 56B

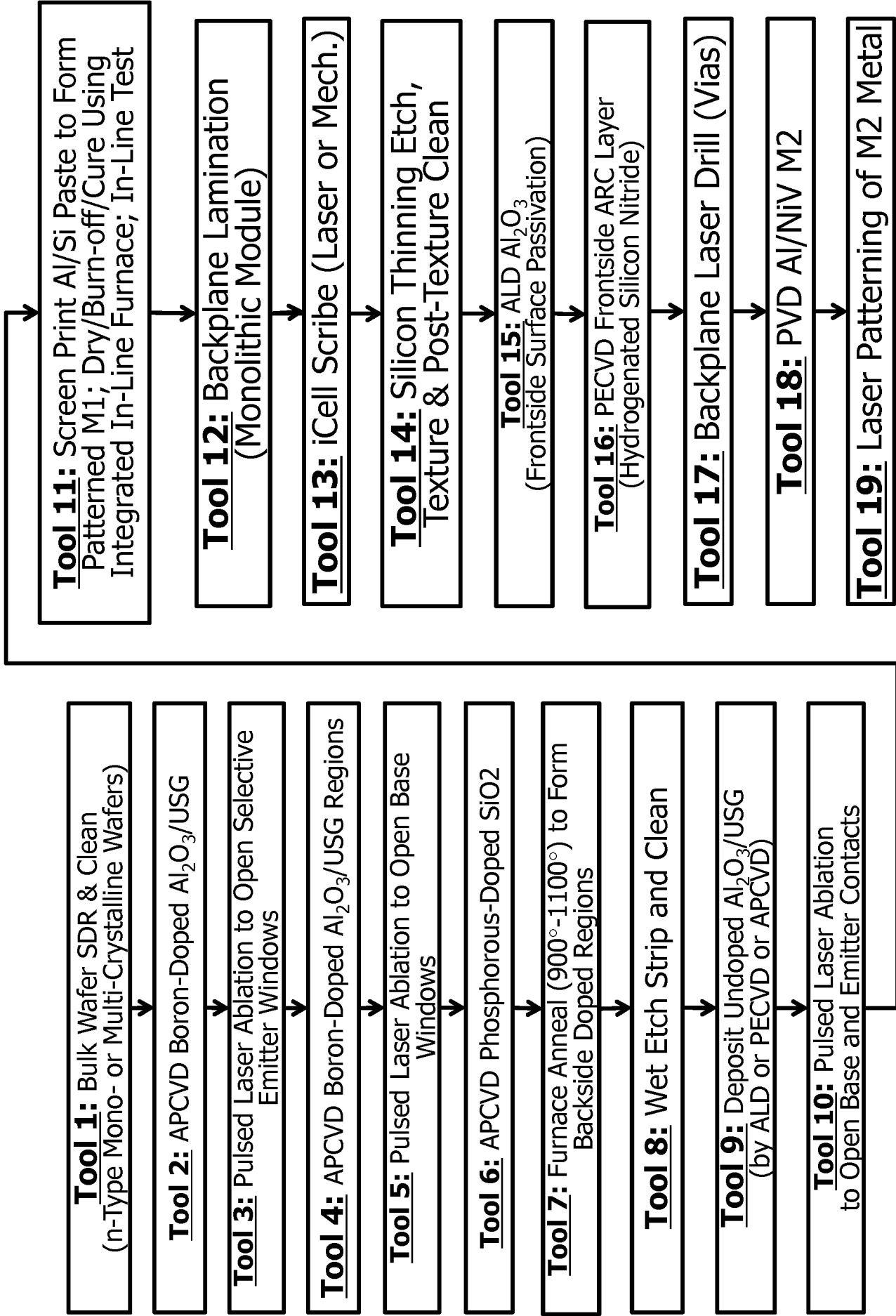


Fig. 57A

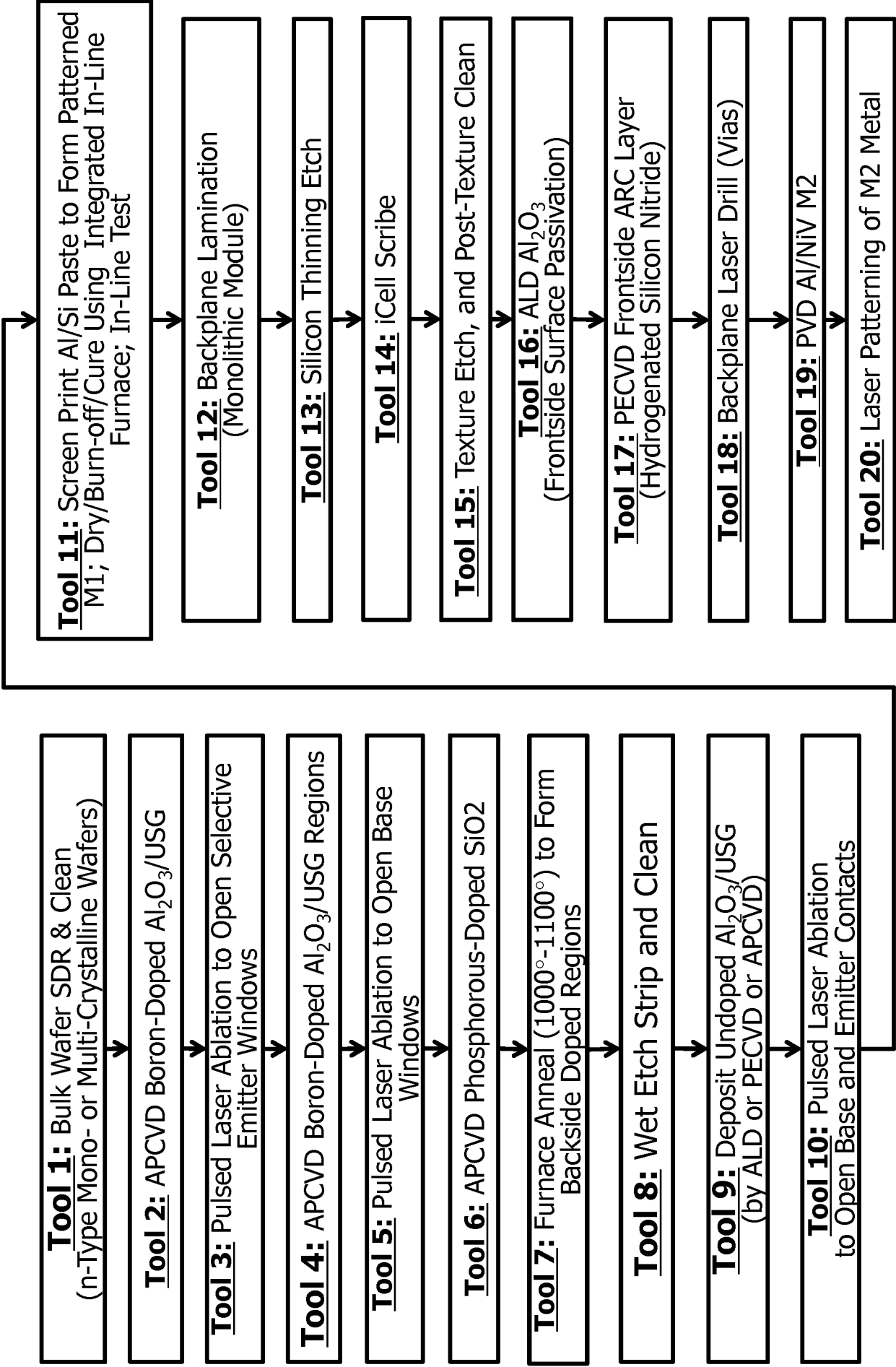


Fig. 57B

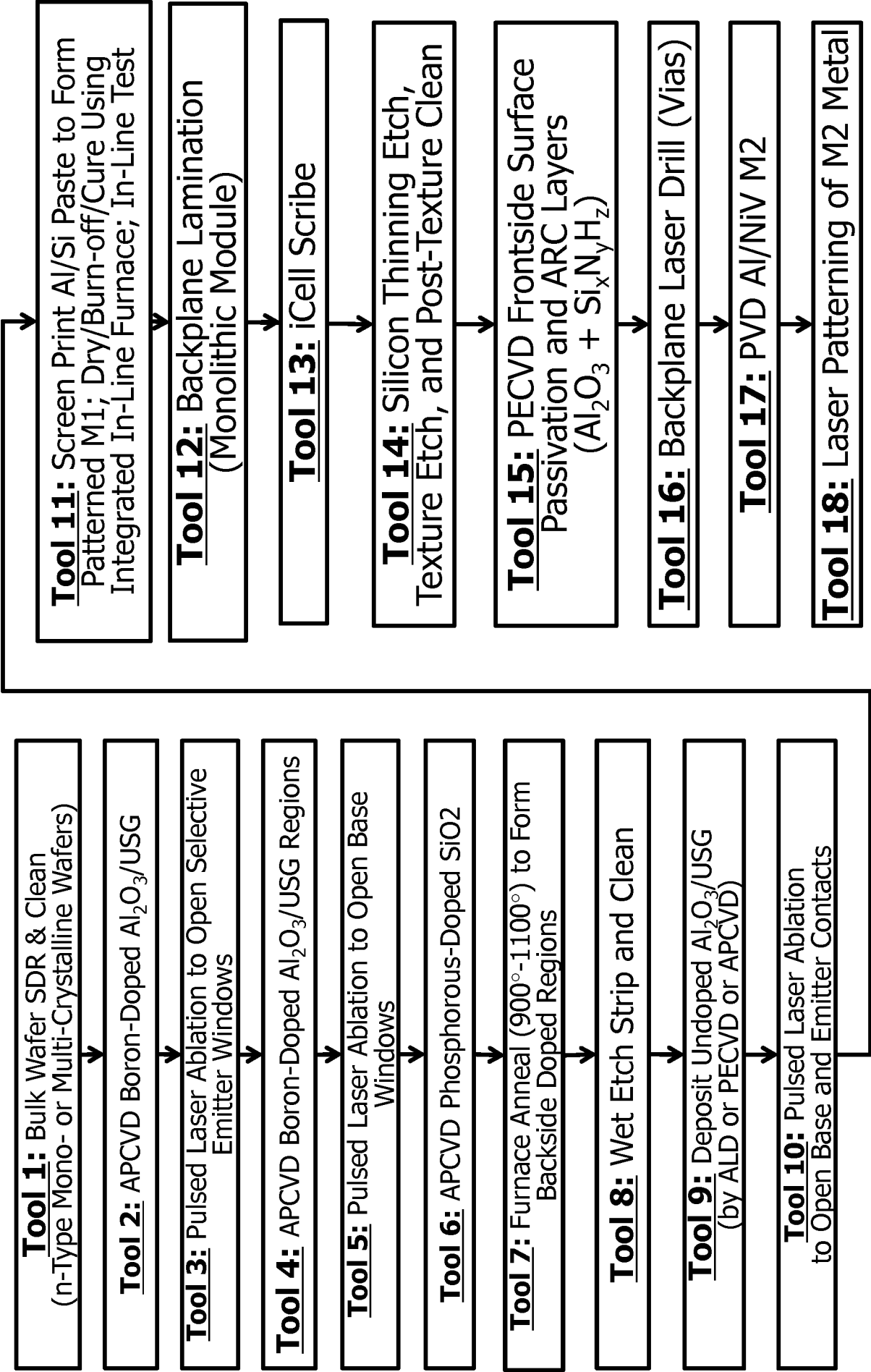


Fig. 58A

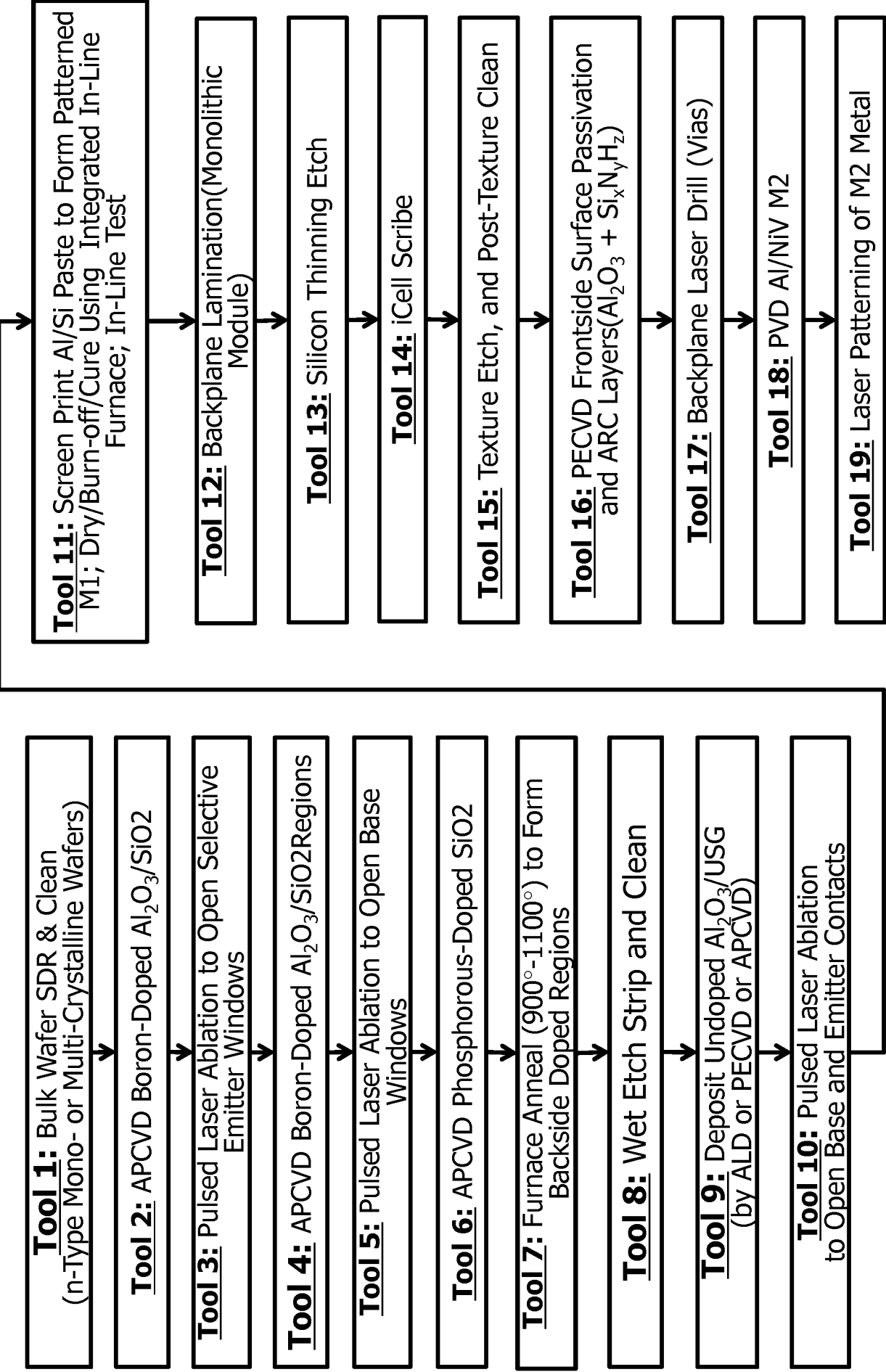


Fig. 58B

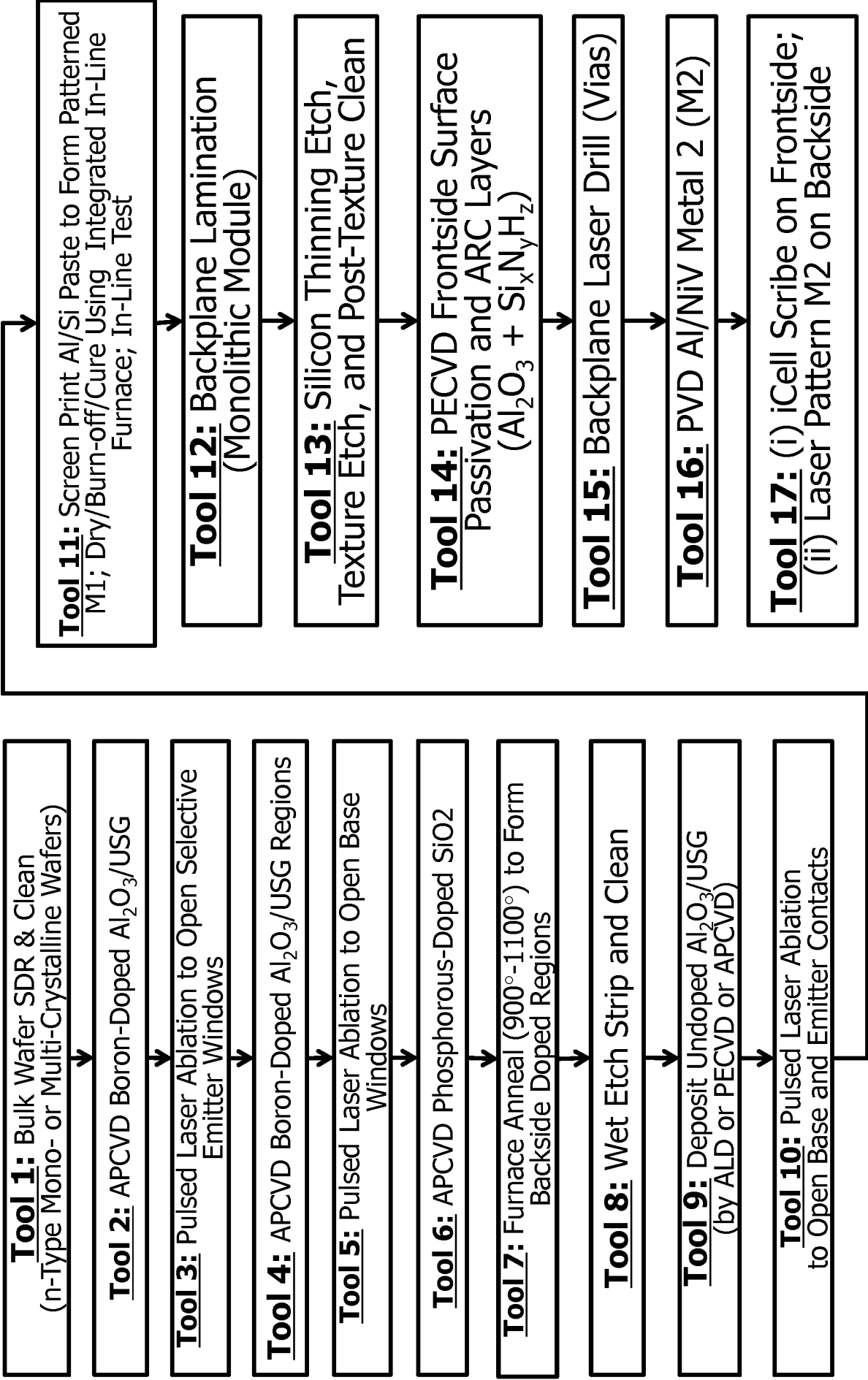


Fig. 59

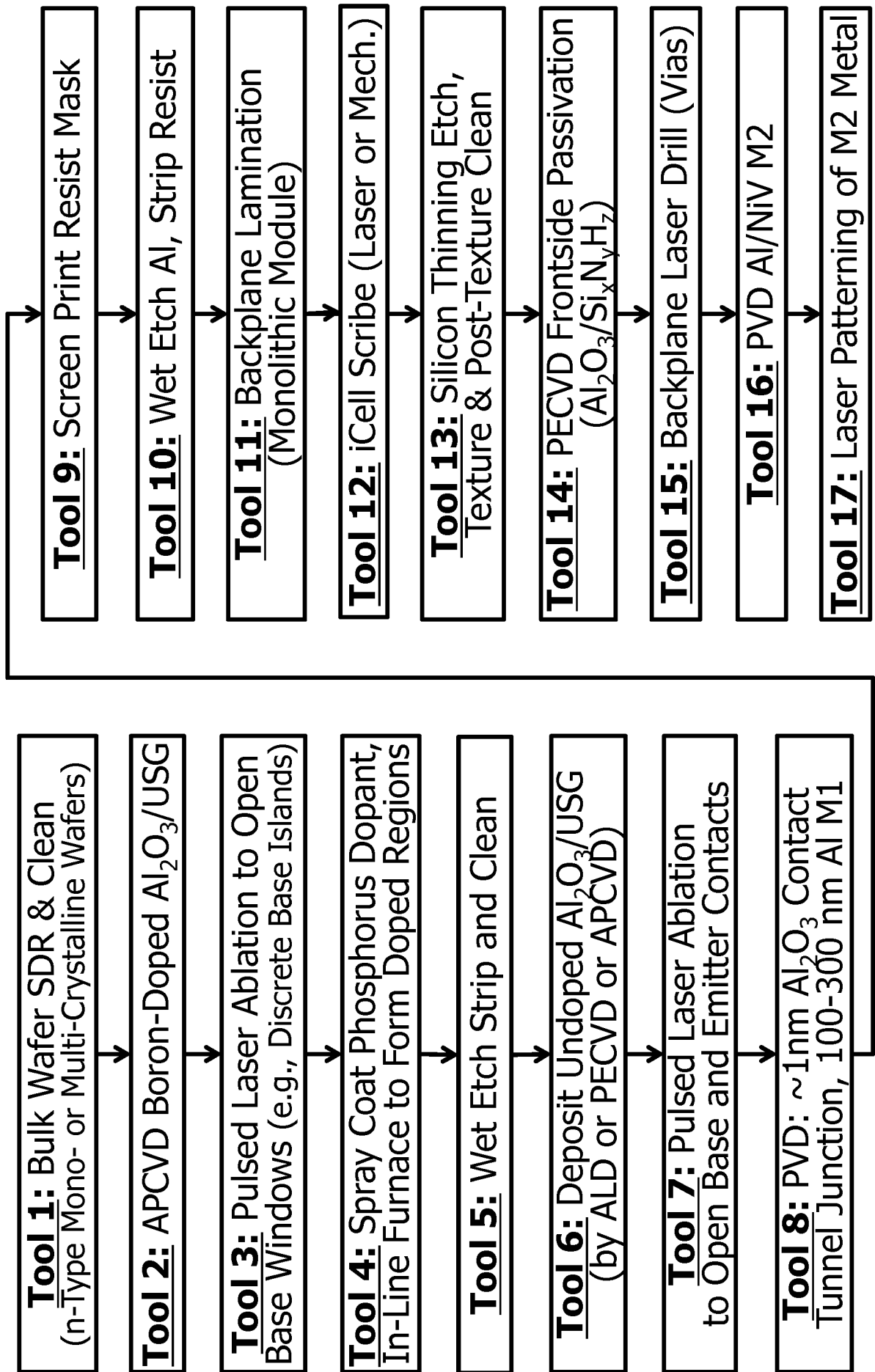


Fig. 60

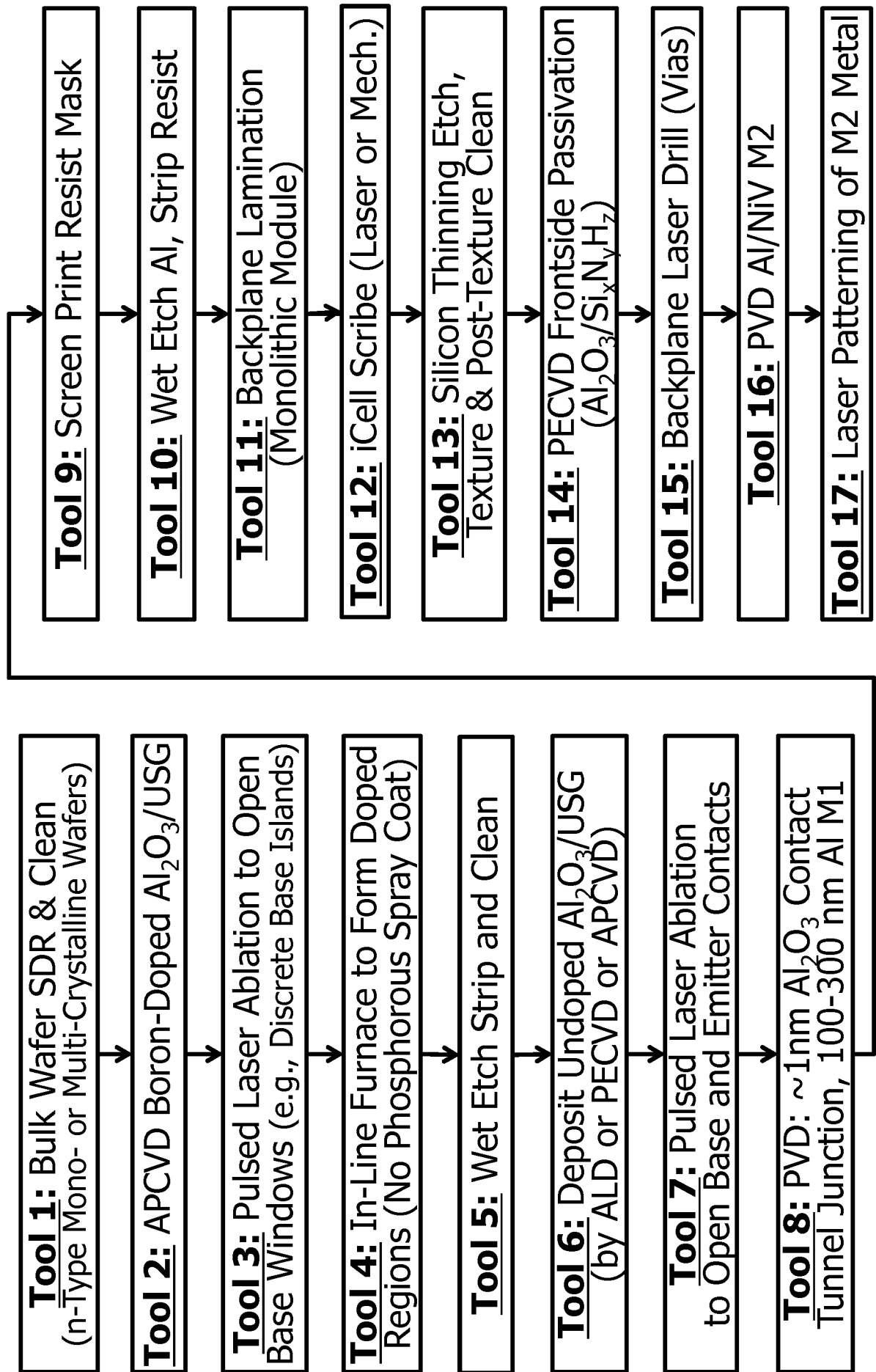


Fig. 61

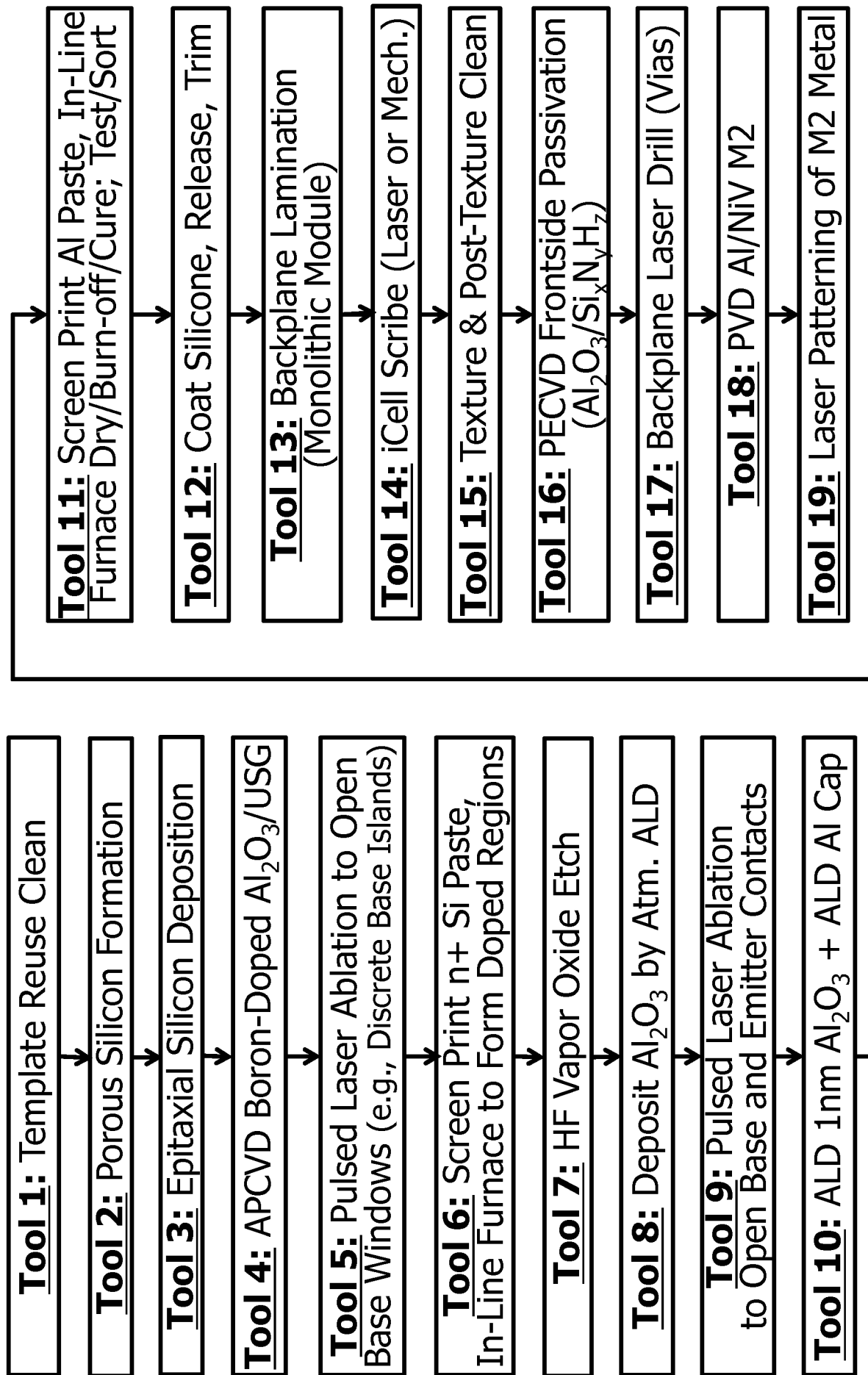


Fig. 62

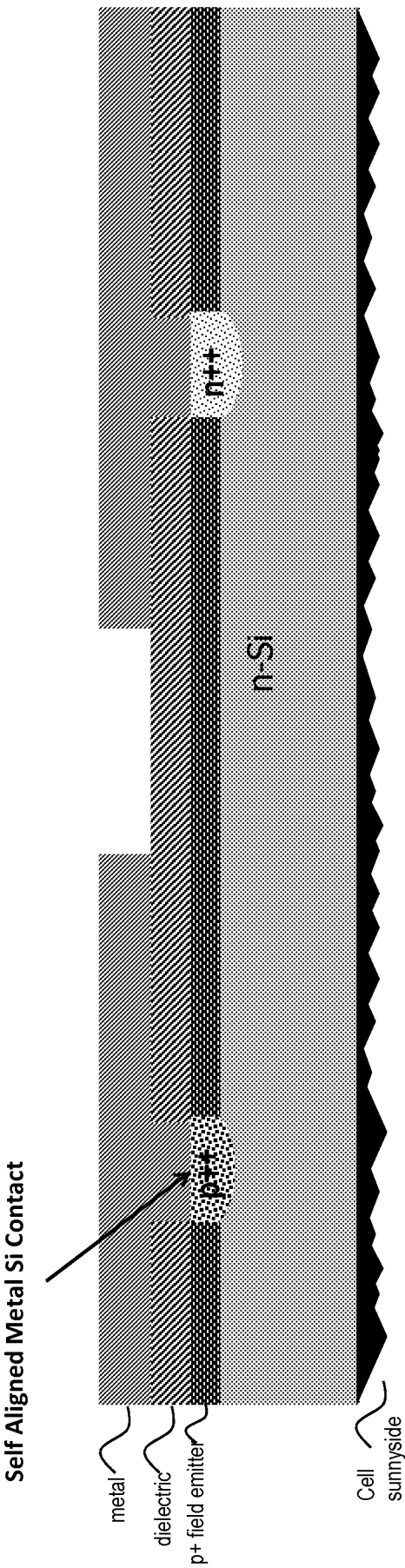


Fig. 63A

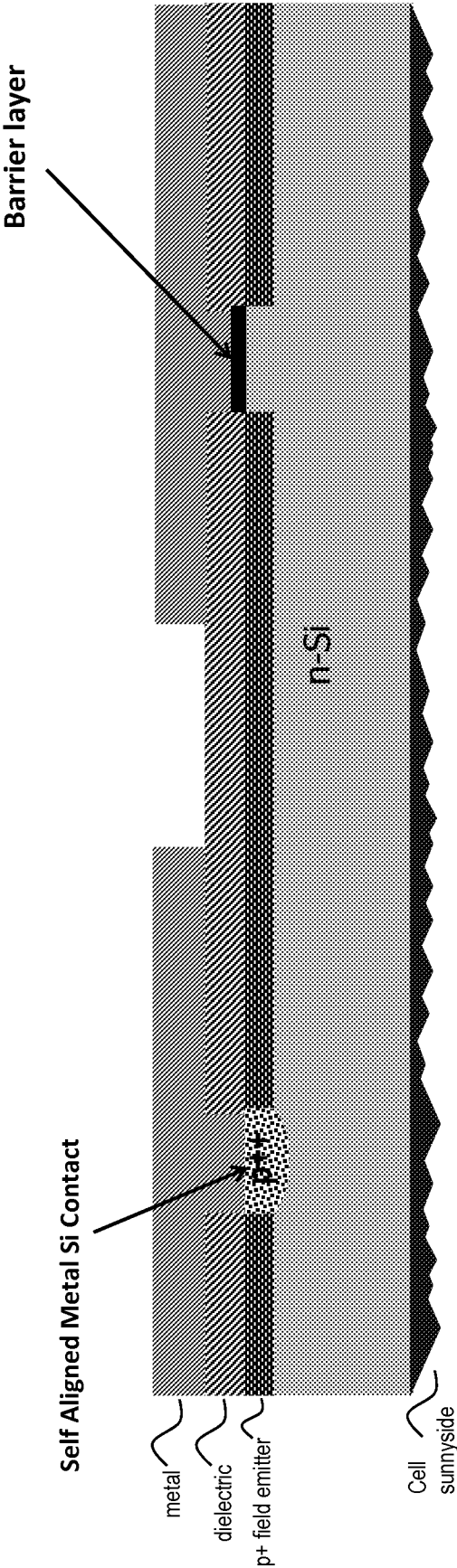


Fig. 63B

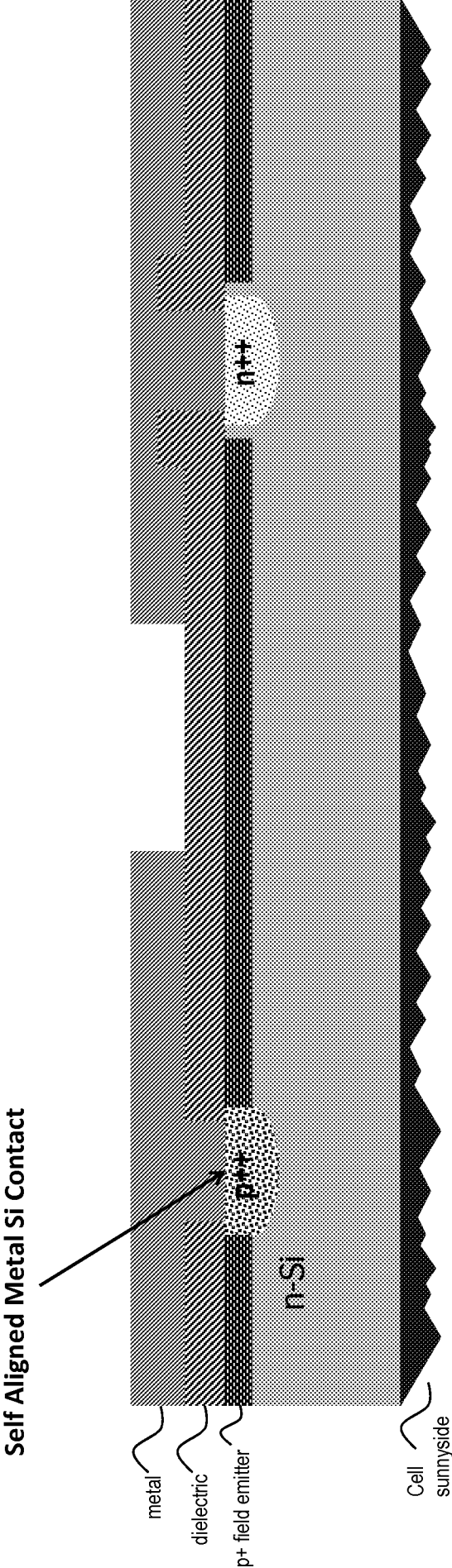


Fig. 63C

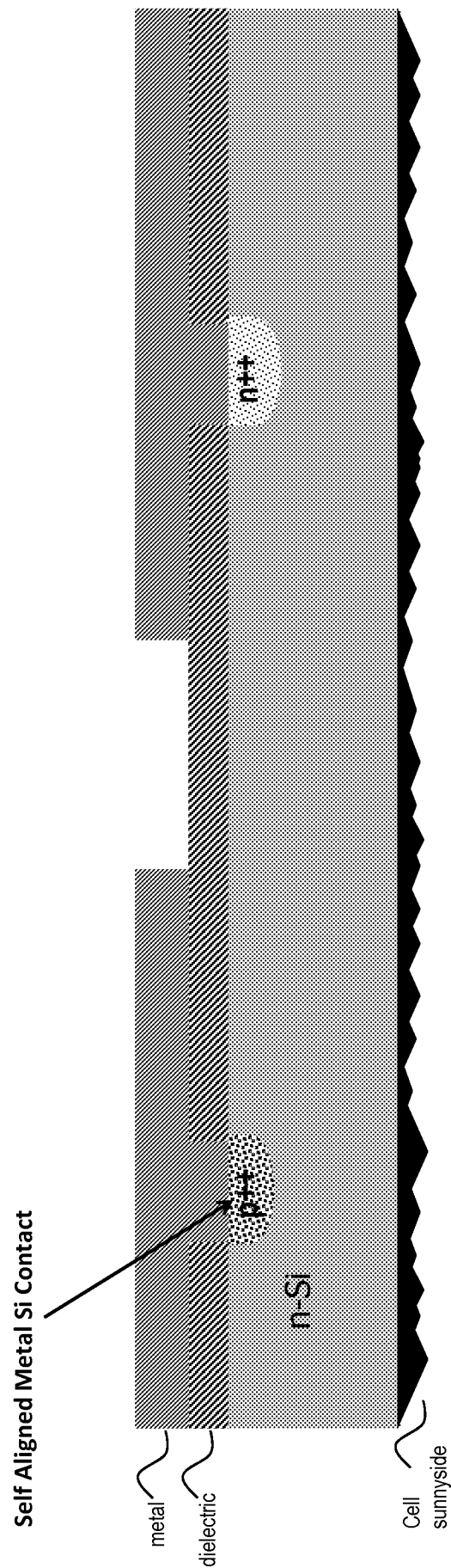


Fig. 63D

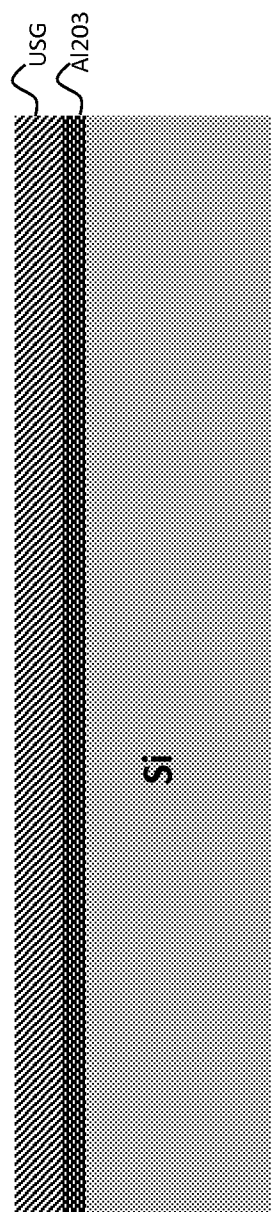


Fig. 64A

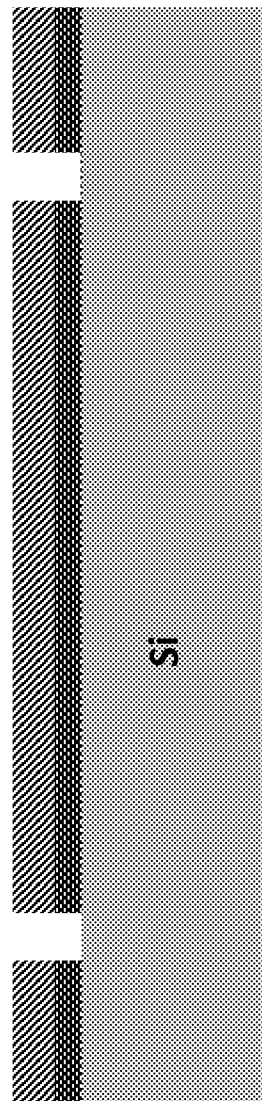


Fig. 64B

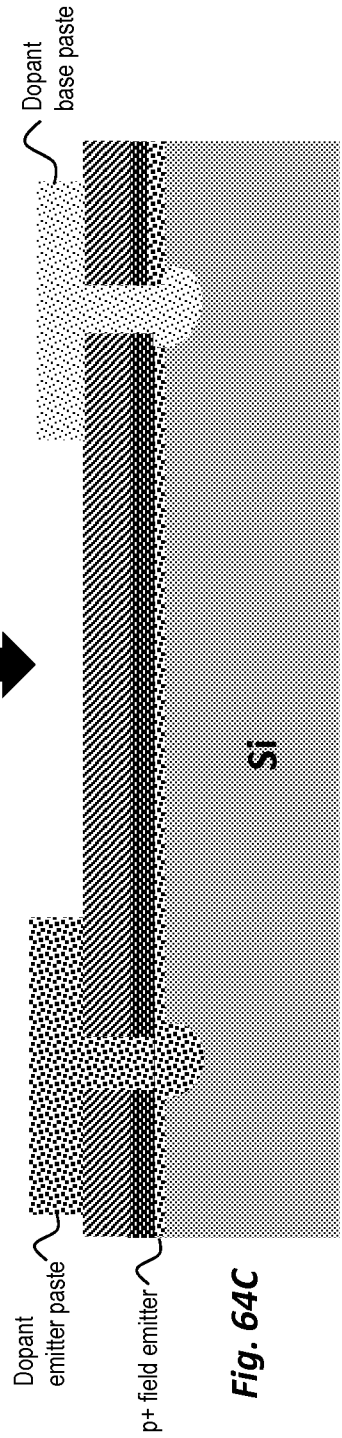


Fig. 64C



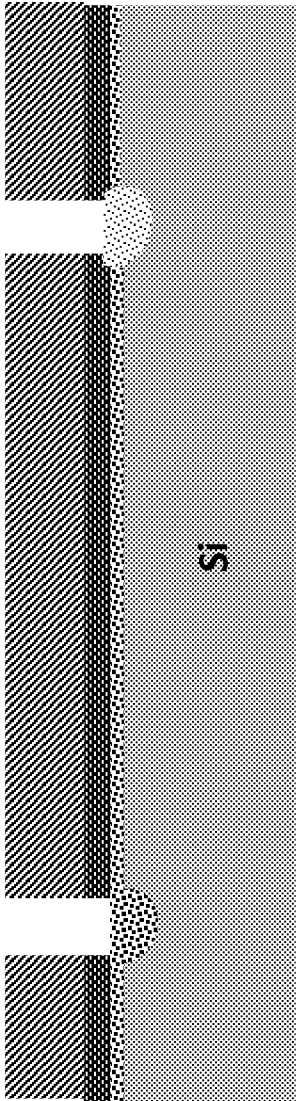


Fig. 64D

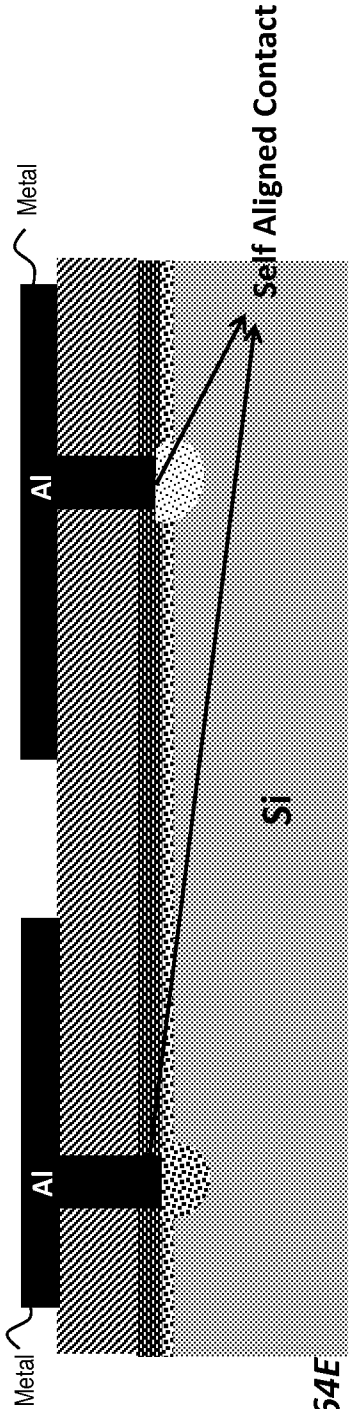


Fig. 64E

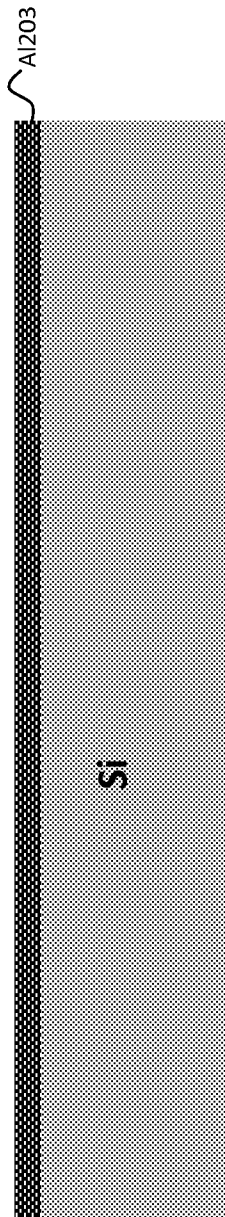


Fig. 65A

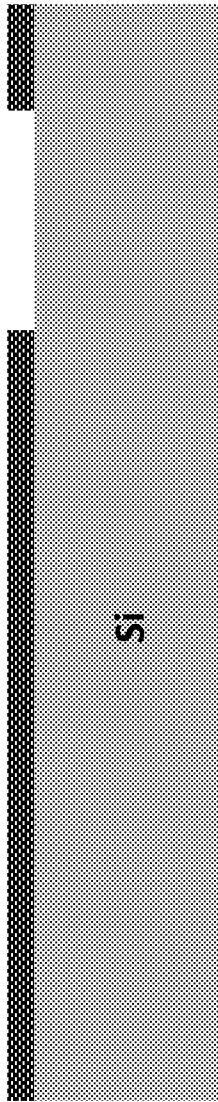


Fig. 65B

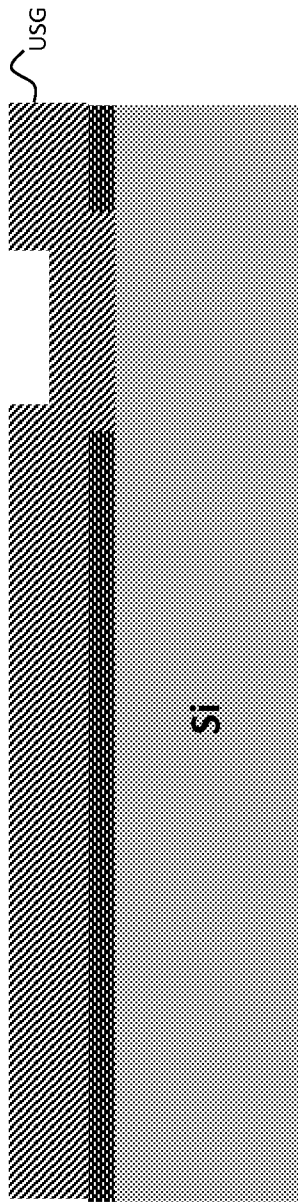


Fig. 65C



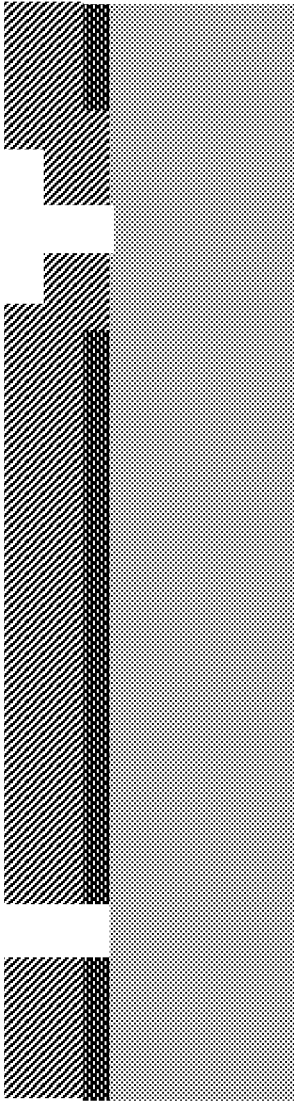


Fig. 65D

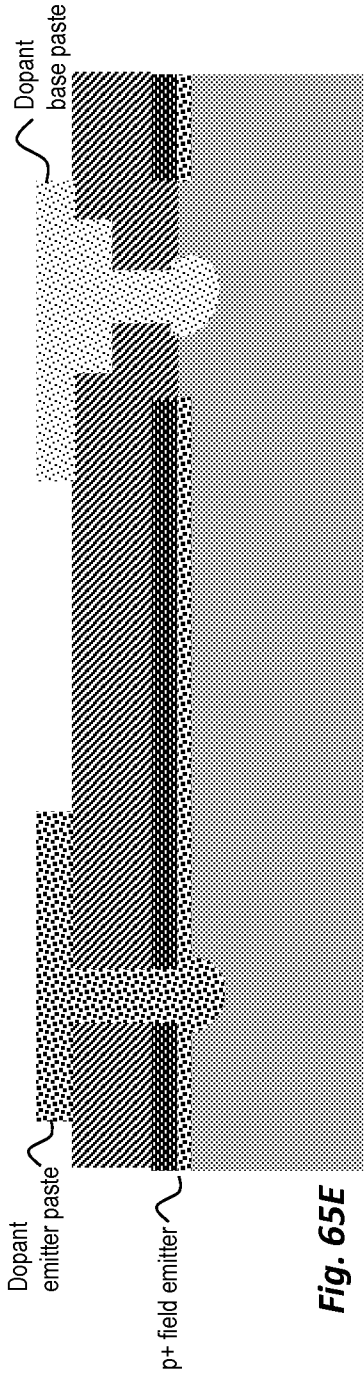


Fig. 65E

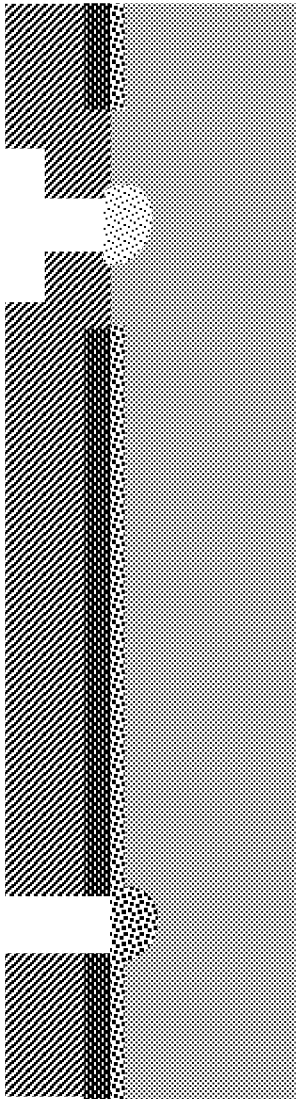


Fig. 65F

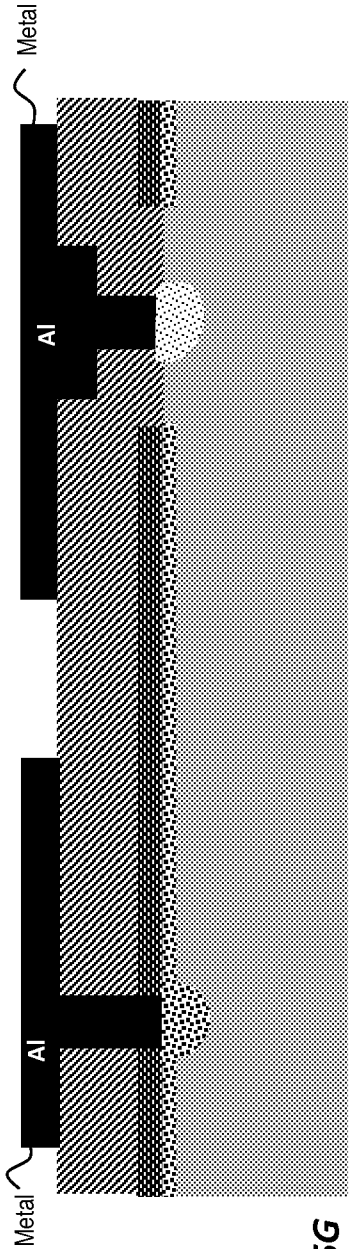


Fig. 65G

